

IMPROVED RF NOISE MODELING FOR SILICON-GERMANIUM
HETEROJUNCTION BIPOLAR TRANSISTORS

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Kejun Xia

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DISSERTATION ABSTRACT

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Accurate radio frequency (RF) noise models for individual transistors are critical to minimize noise during mixed-signal analog and RF circuit design. This dissertation proposes two improved RF noise models for SiGe Heterojunction Bipolar Transistors (SiGe HBTs), a semi-empirical model and a physical model. A new parameter extraction method for small signal equivalent circuit of SiGe HBT has also been developed.

The semi-empirical model extracts intrinsic base and collector current noise from measured device noise parameters using standard noise de-embedding method based on a quasi-static input equivalent circuit. Equations are then developed to model these noise sources by examining the frequency and bias dependences. The model is shown to work at frequencies up to at least half of the peak unit-gain cutoff frequency (f_T), and at biasing currents below high injection f_T roll off. The model is scalable for emitter geometry, and can be easily implemented using currently available CAD tools.

For the physical model, improved electron and hole noise models are developed. The impact of the collector-base space charge region (CB SCR) on electron RF noise is examined to determine

its importance for scaled SiGe HBTs. The van Vliet model is then improved to take into account the CB SCR effect. The fringe EB junction effect is included to improve base hole noise. The base noise resistance is found to be different from the AC intrinsic base resistance, which cannot be explained by the fringe effect. Applying a total of four bias-independent model parameters, the combination of new electron and hole noise models based on a non-quasistatic input equivalent circuit provides excellent noise parameter fittings for frequencies up to 26 GHz and all biases before f_T roll off for three generations of SiGe HBTs. The model also has a good emitter geometry scaling ability.

The new small signal parameter extraction method developed here is based on a Taylor expansion analysis of transistor Y-parameters. This method is capable of extracting both input non-quasistatic effect and output non-quasistatic effect, which are not available for any of the existing extraction methods.

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CHAPTER 1

INTRODUCTION

This chapter opens with a discussion of the motivation for this research on improving RF noise modeling for SiGe Heterojunction Bipolar Transistors (SiGe HBTs). The fundamentals of SiGe HBT physics and the two-port noise representation theory are then introduced, followed by a description of the basic characteristics of noise parameters for SiGe HBTs and the noise performance scaling trend. Finally the chapter is summarized and the organization of this dissertation is provided.

1.1 Motivation

The rapidly developing wireless communication systems have given the human race an information net composed of thousands of communication satellites in space, millions of base-stations on the ground and billions of personal communicators in people's hands. Detailed studies on reducing the noise in the mixed-signal analog and RF circuits used in wireless systems are therefore vital to improve the sensitivity of transceivers, and thus save base-station density and enhance the flexibility of handsets. One of the key concerns is the minimization of RF noise in transistor amplifiers through device level design and circuit level design.

By introducing a graded germanium profile in the base and a higher level of base doping, SiGe HBT enjoys a higher unit-gain cutoff frequency and a smaller base resistance than traditional Silicon Bipolar Transistors (Si BJTs) and maintains a comparable current gain [1]. All these features contribute to the lower noise level of SiGe HBTs compared to Si BJTs.

For RF circuits based on SiGe HBTs, optimizing the design is very important to reduce noise. This clearly requires accurate SiGe HBT noise models and efficient parameter extraction techniques, particularly at the increasingly higher frequencies. The noise modeling approaches currently used for the compact bipolar models are not sufficiently accurate for robust circuit simulation [1], and must be refined to make possible predictive low-noise RF circuit design.

The purpose of this study is to improve RF noise modeling for SiGe HBTs by developing more accurate compact models for intrinsic transistor noise sources. A semi-empirical noise model and a physical noise model are presented in this dissertation. A novel small signal parameter extraction method is also presented. These results were presented in the 2006 *IEEE Transactions on Electron Devices* [2], the 2004, 2005 and 2006 *IEEE BCTM Conference Proceedings* [3–6], and the 2006 *IEEE SiRF Conference Proceedings* [7], while others are forth coming [8,9].

1.2 SiGe HBT fundamentals

1.2.1 SiGe as base material

The key feature of SiGe HBT is the use of SiGe alloy as the base. Since the energy bandgap of Ge (0.66 eV) is smaller than that of Si (1.12 eV), the bandgap of SiGe is smaller than that of silicon and depends on the Ge mole composition x ($\Delta E_{g, SiGe} = 0.74x$). The Ge-induced band offset occurs predominantly in the valence band. A properly defined base Ge profile determines the DC, AC and noise characteristics of SiGe HBTs, and gives SiGe HBTs performance advantages over silicon BJTs [1]. Fig. 1.1 shows a typically graded Ge profile and the resulting energy band diagram for a SiGe HBT. The band diagram shows a finite band offset at the EB junction, denoted as ΔE_{g0} , along with a larger band offset at the CB junction, leading to a built-in electric field in the neutral base region that facilitates electron transport from emitter to collector and hence reduces base transit time and improves AC frequency response. If the profile is linear and the base doping

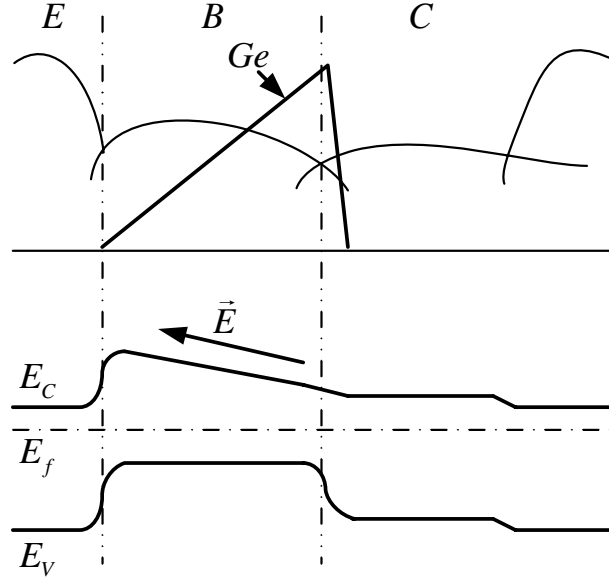


Figure 1.1: Energy band diagram of a graded-base SiGe HBT.

is uniform, the built-in field is homogeneous within the base region, that is

$$E = -\frac{\eta V_T}{d_B}, \quad (1.1)$$

where d_B is the base width, η denotes the difference between the bandgaps at the two base ends in unit of thermal voltage, i.e. $\eta = \Delta E_{g,Ge}(grade)/V_T$. Another important consequence of a graded Ge profile is the exponentially decreasing output conductance g_o , which is reflected by the Early voltage, V_A . g_o is negligible for SiGe HBTs.

The concept of adding a *drift* field in the base is surprisingly old, and was pioneered by Kroemer [10, 11]. However, it took 30 years to realize due to material growth limitations. Nowadays, SiGe alloy can be grown epitaxially on silicon using the ultrahigh vacuum / chemical vapor deposition (UHV/CVD) technique.

For SiGe HBT, the addition of Ge in the base increases the collector current density, J_C . This is made possible by the increased electron injection at the EB junction, which yields more

emitter-to-collector charge transport for a given BE voltage. Such an increase in J_C also results in an increase in the DC current gain, β . Consequently the base doping can be increased if the DC current gain is maintained at the same level as for Si BJTs. This reduces the base resistance, leading to further improved AC performance and reduced RF noise.

Fig. 1.2 shows the cross-sectional structure of a raised-base SiGe HBT [12]. Carbon is doped during SiGe epitaxy to prevent boron backward diffusion into collector. Selectively Implanted Collector (SIC) [13] and Shallow Trench Isolation (STI) [14] are used to improve transistor performance. These techniques will be described in detail below. The most important parasitics are labeled in Fig. 1.2 and consist of the emitter resistance r_e , extrinsic base resistance r_{bx} , extrinsic collector resistance r_{cx} , substrate resistance r_{cs} , extrinsic EB capacitance C_{bex} , extrinsic CB capacitance C_{bcx} , and collector-substrate junction capacitance C_{cs} . The intrinsic base resistance r_{bi} , intrinsic CB capacitance C_{bci} and intrinsic collector resistance r_{ci} are also shown for reference.

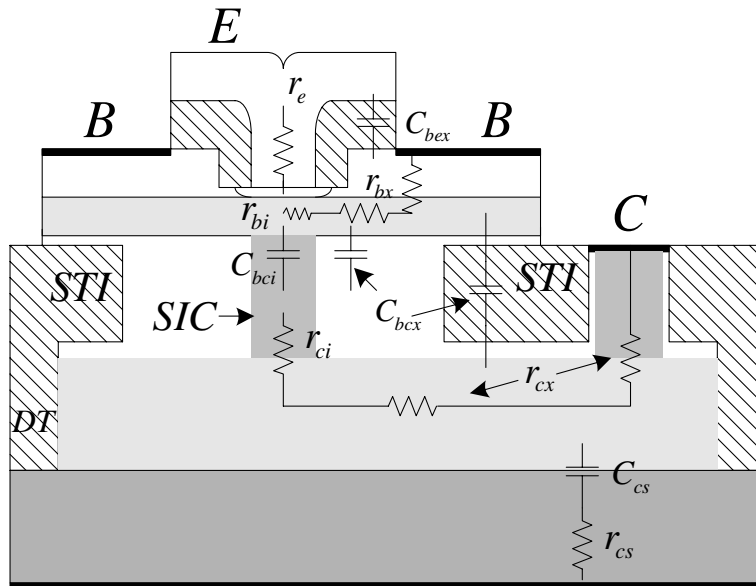


Figure 1.2: Cross section of a raised-base SiGe HBT. Main parasitics are labeled.

1.2.2 Performance parameters

For low injection, a key SiGe HBT AC figure-of-merit, the unity-gain cutoff frequency (f_T), can be written generally as [1]

$$f_T = \frac{1}{2\pi\tau_{ec}} \approx \frac{1}{2\pi} \left[\frac{C_{bej} + C_{bcx} + C_{bci}}{g_m} + \tau_{tr}^b + \tau_e + \tau_c + (r_e + r_{cx} + r_{ci})(C_{bcx} + C_{bci}) \right]^{-1}, \quad (1.2)$$

where τ_{ec} is the total emitter-to-collector delay time, g_m ($\approx qI_c/kT$) is the intrinsic transconductance at low injection, C_{bej} is the EB depletion capacitance, τ_{tr}^b is the base transit time, τ_e is the emitter charge storage delay time, and τ_c is the collector transit time due to the CB space charge region (CB SCR). Physically, f_T is the common-emitter, unity current gain cutoff frequency ($H_{21} = 1$), and can be conveniently measured using S-parameter techniques. f_T can be improved by reducing transit times and using a smaller resistive collector. For an ideal HBT, f_T increases versus collector current I_c and finally saturates, a direct result of (1.2). However in reality, f_T will roll-off when I_c exceeds some threshold value due to the Kirk effect or base push-out [15]. That is, f_T has a peak value at certain current density $J_{C,peak}$.

Another figure-of-merit that is often used to describe device AC performance is the maximum oscillation frequency f_{max} , reflecting the power gain of a transistor. f_{max} is the common-emitter, unity power gain frequency, and can be related to f_T by a first order equation [1]

$$f_{max} \approx \sqrt{\frac{f_T}{8\pi(C_{bci} + C_{bcx})(r_{bx} + r_{bi})}}. \quad (1.3)$$

There are various definitions of power gain (e.g. U, MAG, MSG), all of which can be measured from the S-parameters [1]. Clearly f_{max} depends not only on the intrinsic transistor performance (f_T), but also on the device parasitics associated with the process technology and its structural implementation. Reducing the base resistance and CB capacitance is decisive for improving f_{max} .

For general applications, the CB junction is reversely biased. If V_{CB} is high enough, ionization occurs within the CB SCR. I_c increases dramatically due to carrier multiplication, resulting in device breakdown. BV_{CBO} is the CB breakdown voltage when the emitter is floated. BV_{CEO} is the CB breakdown voltage when the base floats. As shown below, increasing BV_{CEO} will decrease f_T . Product $BV_{CEO} \times f_T$, the so-called Johnson limit, is a physical constraint on device optimization.

1.2.3 Improving f_T and f_{max}

Common sense dictates that for transistors, the smaller they are, the faster they will perform. Indeed, the performance of SiGe HBTs has been greatly enhanced by scaling down accompanied with innovative structure designs, both in vertical and lateral dimensions. The f_T of the first functional SiGe HBT demonstrated in 1987 [16] is about 50 GHz. Nowadays, SiGe HBTs with both f_T and f_{max} greater than 300 GHz have been achieved [17], and this trend continues.

Vertical scaling

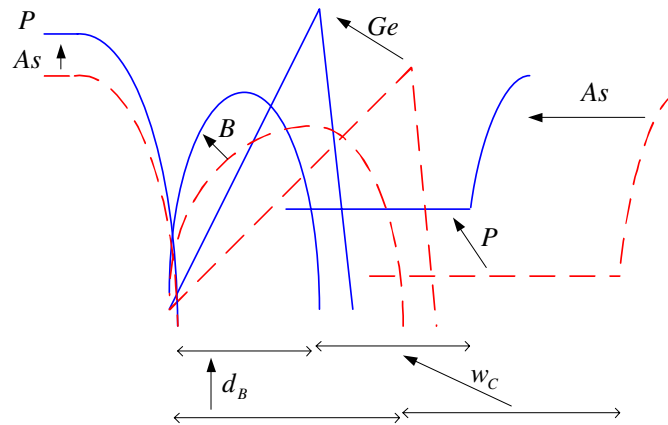


Figure 1.3: Vertical scaling strategy for SiGe HBT.

Fig. 1.3 illustrates the vertical scaling strategy.

- *Base* Here the base width d_B is reduced, and a higher Ge ramp is applied, both of which help to reduce base transit time τ_{tr}^b . For advanced devices, e.g. 200 GHz SiGe HBTs, τ_{tr}^b is less than the total of other transit times. Base doping is also increased to reduce base resistance.
- *Collector* A higher collector doping N_C and a narrower lightly doped collector thickness w_C are used to reduce collector transit time τ_c . For aggressively scaled devices, τ_c dominates the total transit time. A higher level of doping also helps to defer the Kirk effect. However, the breakdown voltage is reduced due to the higher CB SCR electric field. Additionally, higher collector doping leads to larger CB capacitance, which reduces f_{max} . Therefore, there is a trade off between f_T , f_{max} and breakdown voltage for N_C .
- *Emitter* The doping is increased to reduce r_e and τ_e , and the arsenic dopant can be replaced with phosphorus to obtain higher doping concentrations. Generally speaking, τ_e is negligible due to HBT's high DC current gain β .

Lateral scaling

The emitter width W_E is the key factor for lateral scaling, and generally serves as an indicator of the technology generation. When W_E is narrowed, both the intrinsic base resistance r_{bi} and the intrinsic CB capacitance C_{bci} are reduced, and hence f_{max} is improved. f_T , however, cannot be improved by this approach. With W_E scaled down, extrinsic base and collector parasitics become significant for f_{max} , and must be reduced by scaling and *ad hoc* techniques .

- R_{bx} Increasing base doping will reduce R_{bx} , but at the price of increasing the CB capacitance. The solution to this dilemma is to use the so called raised base technique, as shown in Fig. 1.2 [12], where highly doped polysilicon is deposited on top of the SiGe:C layer. Self-aligned low resistive silicide is generally used for such a raised extrinsic base, and a double base contact can be used to reduce the base resistance further.

- C_{bcx} Using implantation through the emitter window, only the collector of the intrinsic device is highly doped to obtain high f_T . The remainder of the collector, which is on top of the highly doped collector buried layer, is lightly doped to obtain small C_{bcx} . This is known as the Selectively Implanted Collector (SIC) technique [13]. Shallow trench isolation [14], as shown in Fig. 1.2, can be used to reduce C_{bcx} further by reducing the extrinsic CB junction area.

Table 1.1 summarizes the key performance parameters for the five generations of SiGe HBTs readily fabricated in industry [18].

Table 1.1: Comparison of key performance parameters for different SiGe HBT generations [18]

Generation	I	II	III	IV	V
W_E (μm)	0.5	0.25	0.18	0.13	0.12
f_T (GHz)	47	47	120	210	375
f_{max} (GHz)	65	65	100	285	210
β	100	100	350	300	3500
BV_{CEO} (V)	3.4	3.4	1.8	1.7	1.4
BV_{CBO} (V)	10.5	10.5	6.5	5.5	5.0
$J_{C,peak}$ ($\text{mA}/\mu\text{m}^2$)	1.5	1.5	8	12	23

1.2.4 SiGe BiCOMS technology

Today's SiGe HBT technology combines the high speed, low noise SiGe HBTs, aggressively scaled Si CMOS, and a full-suite of on-chip passives together, to create the so-called SiGe BiCMOS technology. SiGe technology has thus emerged as a serious contender for many high-speed digital, RF, analog and microwave applications [1]. At present, there are more than 25 SiGe HBT industrial fabrication facilities on line, and their numbers are growing steadily. Design kits for first four generations of SiGe BiCMOS systems have already been released by IBM. More details of the industrial "state-of-the-art" for SiGe HBT BiCMOS technology can be found in [19].

1.3 Noise parameters for two-port network

In this study, the substrate of the SiGe HBT is always tied to its collector to facilitate S-parameter measurements using a GSG probing system. The resulting SiGe HBT is a two-port network. The noise level of such two-port networks can be measured in terms of *Noise Factor*, F , which is defined as

$$F = \frac{(SNR)_{signal\ source}}{(SNR)_{output}}. \quad (1.4)$$

Here SNR is the signal-to-noise power ratio. F is usually measured in dB and its value is referred to as the *Noise Figure* NF , i.e. $NF = 10\text{Log}_{10}(F)$. For a two-port network connected to a signal source, F is determined by both the *noise parameters* (F_{min} or NF_{min} , R_n and Y_{opt}) of the two-port network and the signal source admittance Y_S as [20]

$$NF = NF_{min} + \frac{R_n}{G_S} |Y_S - Y_{opt}|^2, \quad (1.5)$$

where G_S is the real part of Y_S . The noise parameters can be measured using noise measurement facilities, and their meanings can be explained as follows:

- F_{min} , the minimum noise factor. Its value in dB is the so called minimum noise figure NF_{min} , i.e. $10\text{Log}_{10}(F_{min})$.
- R_n , the noise resistance, is commonly normalized by the intrinsic impedance Z_0 , and thus is unitless.
- Y_{opt} , the optimum noise matching admittance, is a complex number with a real part G_{opt} and an imaginary part B_{opt} . Its inverse value is denoted as Z_{opt} . Experimentally, the reflection coefficient Γ_{opt} is measured instead of Y_{opt} . Note that $\Gamma_{opt} = \text{Mag} \cdot e^{(j \cdot \text{Angle}/180 \cdot \pi)}$. Y_{opt} can

be obtained from Γ_{opt} as

$$Y_{opt} = \frac{1}{Z_0} \cdot \frac{1 - \Gamma_{opt}}{1 + \Gamma_{opt}}$$

(1.5) implies that if a two-port network is noise matched ($Y_S = Y_{opt}$), the noise figure is minimized.

The available power gain under noise matching conditions is known as the associated power gain,

G_A^{ass} . It can be calculated by

$$G_A^{ass} = \left| \frac{Y_{21}}{Y_{11} + Y_{opt}} \right|^2 \frac{G_{opt}}{\Re[Y_{22} - (Y_{12}Y_{21})/(Y_{11} + Y_{opt})]}$$

The noise parameters of a two-port network are fully determined by the noise sources that are distributed within the network. All of the distributive noises can be lumped into two equivalent noise sources located at the port terminals, and they are generally correlated [20]. Fig.1.4 shows four commonly used representations for lumped noise sources, (a) admittance or Y- representation, (b) impedance or Z- representation, (c) chain or ABCD- or A- presentation, and (d) hybrid or H- representation. Note the source polarities in (c) and (d). For each representation, the noise Power

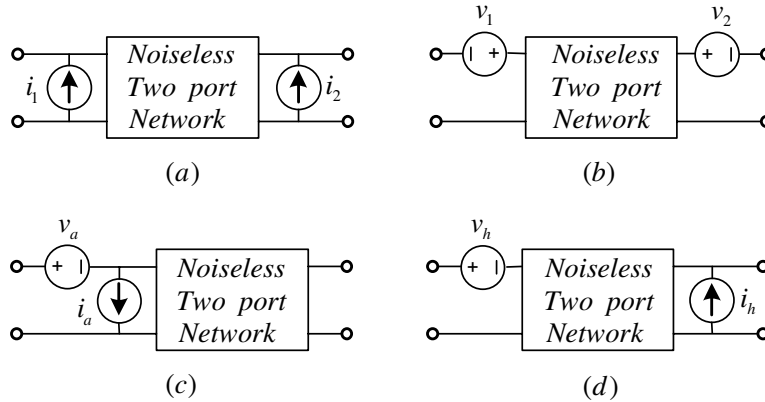


Figure 1.4: Two-port noise representations. (a) Admittance (Y-) representation, (b) Impedance (Z-) representation, (c) Chain (ABCD-) presentation, and (d) hybrid (H-) representation.

Spectral Density (PSD) of the two noise sources, as well as their correlation, can be described by a noise correlation matrix at each frequency point (ω). PSD matrices for the four representations are defined as

$$\begin{aligned} S^Y(\omega) &= \begin{bmatrix} S_{i_1 i_1^*}(\omega) & S_{i_1 i_2^*}(\omega) \\ S_{i_1 i_1^*}(\omega) & S_{i_2 i_2^*}(\omega) \end{bmatrix}, & S^Z(\omega) &= \begin{bmatrix} S_{v_1 v_1^*}(\omega) & S_{v_1 v_2^*}(\omega) \\ S_{v_2 v_1^*}(\omega) & S_{v_2 v_2^*}(\omega) \end{bmatrix}, \\ S^A(\omega) &= \begin{bmatrix} S_{v_a v_a^*}(\omega) & S_{v_a i_a^*}(\omega) \\ S_{i_a v_a^*}(\omega) & S_{i_a i_a^*}(\omega) \end{bmatrix}, & S^H(\omega) &= \begin{bmatrix} S_{v_h v_h^*}(\omega) & S_{v_h i_h^*}(\omega) \\ S_{i_h v_h^*}(\omega) & S_{i_h i_h^*}(\omega) \end{bmatrix}. \end{aligned} \quad (1.6)$$

Each of these matrices, denoted as S^{origin} , can be transformed into another, denoted as $S^{destination}$, by

$$S^{destination} = T S^{origin} T^\dagger. \quad (1.7)$$

Here the superscript \dagger represents the transpose conjugate operator. The T-matrices are summarized in Appendix A.

Noise parameters, determined by lumped noise sources, can be directly calculated from the chain representation noise matrix elements, i.e. S_v , S_i and $S_{i v^*}$ as [20]

$$\begin{aligned} R_n &= \frac{S_v}{4kT}, \\ G_{opt} &= \sqrt{\frac{S_i}{S_v} - \left[\frac{\Im(S_{i v^*})}{S_v} \right]^2}, \\ B_{opt} &= -\frac{\Im(S_{i v^*})}{S_v}, \\ NF_{min} &= 1 + 2R_n \left[G_{opt} + \frac{\Re(S_{i v^*})}{S_v} \right]. \end{aligned} \quad (1.8)$$

The derivation is given in Appendix A. Inversely, the chain representation noise matrix can be calculated from noise parameters using (1.8) as

$$S^A = \begin{bmatrix} S_v & S_{vi^*} \\ S_{iv^*} & S_i \end{bmatrix} = 4kT \begin{bmatrix} R_n & \frac{NF_{min}-1}{2} - R_n Y_{opt}^* \\ \frac{NF_{min}-1}{2} - R_n Y_{opt} & R_n |Y_{opt}|^2 \end{bmatrix}. \quad (1.9)$$

(1.9) will be used in the noise de-embedding procedure described in Chapter 4.

1.4 Frequency and bias dependence of noise parameters for SiGe HBTs

Generally speaking, all the noise parameters are both frequency and bias dependent. Fig. 1.5 shows the measured noise parameters versus collector current I_c for a 50 GHz SiGe HBT with emitter area $A_E = 0.24 \times 20 \times 2 \mu\text{m}^2$. Six frequency points (2 GHz, 5 GHz, 10 GHz, 15 GHz, 20 GHz and 25 GHz) are shown.

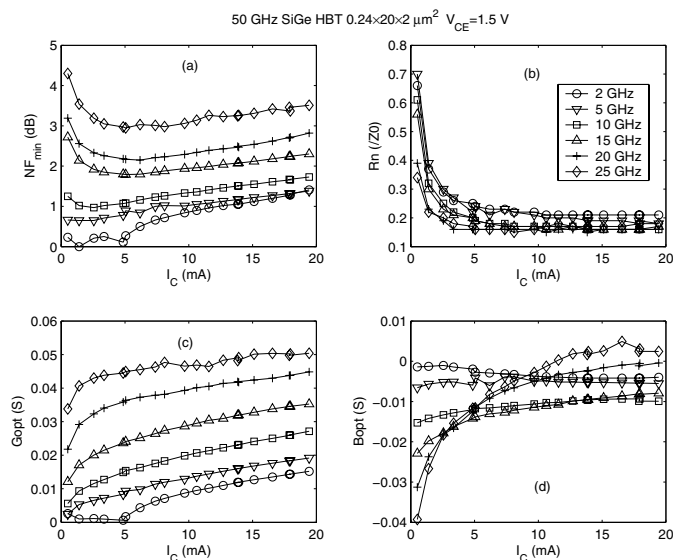


Figure 1.5: Noise parameters versus I_c for a 50 GHz SiGe HBT with $A_E = 0.24 \times 20 \times 2 \mu\text{m}^2$. Six frequency points (2 GHz, 5 GHz, 10 GHz, 15 GHz, 20 GHz and 25 GHz) are measured.

To qualitatively understand these frequency and bias dependence, it is necessary to derive the noise parameters analytically. Fig. 1.6 shows a *simplified* common-emitter small signal equivalent circuit with noise sources for SiGe HBTs. C_{bet} is the total CB capacitance ($= C_{bci} + C_{bcx}$) and r_{bt} is the total base resistance. Since r_e is not included in Fig. 1.6, $r_{bt} \approx r_{bx} + r_{bi} + r_e(1 + \beta)$. C_{bet} is the total EB capacitance, and is the sum of the EB diffusion capacitance C_{bed} and the EB junction depletion capacitance C_{bej} . g_{be} is the EB low frequency conductance. r_{bt} is assumed to have $4kTR$ noise PSD, i.e. $S_{vr_{bt}} = 4kTr_{bt}$. Uncorrelated $2qI$ shot noise PSDs are assumed for the base and collector current noises, i.e. $S_{ib} = 2qI_b$, $S_{ic} = 2qI_c$ and $S_{icib^*} = 0$. CB ionization noise is not taken into account here and throughout this work, since only low V_{CB} operation is concerned. Using the

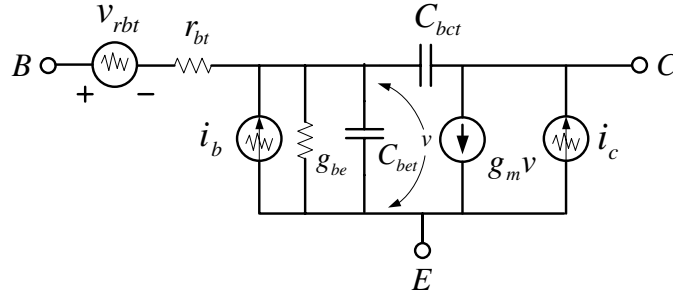


Figure 1.6: Simplified common-emitter small signal equivalent circuit with noise sources for SiGe HBTs.

two-port network noise theory in Section 1.3, the noise parameters can be derived as [19]

$$F_{min} \approx 1 + \frac{N}{\beta} + \sqrt{\frac{2I_c}{V_T} r_{bt} \left(\frac{f^2}{f_T^2} + \frac{1}{\beta} + \frac{N^2}{\beta} \right)} \approx 1 + \sqrt{\frac{2I_c}{V_T} r_{bt} \left(\frac{f^2}{f_T^2} + \frac{1}{\beta} \right)}, \quad (1.10)$$

$$R_n \approx \frac{V_T}{2I_c} + r_{bt}, \quad (1.11)$$

$$Y_{opt} \approx \frac{F_{min} - 1}{2R_n}, \quad (1.12)$$

where N is the EB junction ideality factor and $N \approx 1$.

- NF_{min} or F_{min} (1.10) means that at a fixed bias, NF_{min} increases versus frequency as shown in Fig. 1.5 (a). At low biases, $f_T \propto 1/I_c$ according to (1.2), consequently $F_{min} - 1 \propto 1/\sqrt{I_c}$. Therefore NF_{min} increases when I_c decreases at very low I_c levels. For high biases before f_T roll-off, f_T is nearly constant, hence $F_{min} - 1 \propto \sqrt{I_c}$, meaning that NF_{min} increases versus I_c . These trends are indeed shown in Fig. 1.5 (a). Analysis shows that F_{min} has a minimum value, the so-called optimized noise figure ($Opt. F_{min}$), which is approximately $\sqrt{f} \sqrt{8\pi^2 r_{bt}(C_{bej} + C_{bct})/\beta^{1/2}}$ at low frequencies and $f4\pi \sqrt{2r_{bt}(C_{bej} + C_{bct})(\tau_b + \tau_e + \tau_c)}$ at high frequencies. Increasing f_T and decreasing r_{bt} can significantly reduce the optimized noise figure ($Opt. F_{min}$).
- R_n (1.11) shows that R_n drops versus I_c and saturates to the value of r_{bt} , which is consistent with Fig. 1.5 (b). The frequency dependence cannot be explained using this simplified equivalent circuit.
- Y_{opt} (1.12) shows that the imaginary part of Y_{opt} or B_{opt} is negligible. This is qualitatively true, as can be seen by comparing Fig. 1.5 (d) with Fig. 1.5 (c). The real part of Y_{opt} or G_{opt} increases versus frequency, as shown by Fig. 1.5 (c), which is consistent with (1.12). The bias dependence of G_{opt} , however, cannot be easily explained since both F_{min} and R_n are bias dependent. As Fig. 1.5 (c) shows, G_{opt} increases versus I_c .

1.5 Noise performance trends for SiGe HBTs

Advances in scaling technology and a series of innovations in processing and structure have led to a steady increase in the peak f_T and a reduction in the base resistance r_{bt} . According to the discussion above, these f_T and r_{bt} trends will improve noise performance, driving a reduction in NF_{min} with each generation. SiGe BiCOMS technologies thus enable circuit designers to implement noise-sensitive applications at an increasingly broader frequency range based on silicon technology. Fig. 1.7 shows the optimized noise figure $Opt. F_{min}$ versus frequency for four SiGe

HBT BiCMOS technology generations, including three high performance variants at the 0.5-, 0.18-, and 0.13- μm nodes as well as a cost-reduced (and slightly higher breakdown voltage) variant at the 0.18- μm node. The performance of GaAs PHEMT is also illustrated for reference. The noise figure has been greatly decreased for the 0.13- μm node. F_{min} remains below 0.4 dB beyond 12 GHz, rising to only 1.3 dB at 26.5 GHz. This level of performance falls within the range established using the data sheets for GaAs PHEMT currently on the commercial market, placing silicon within one generation of this benchmark [19].

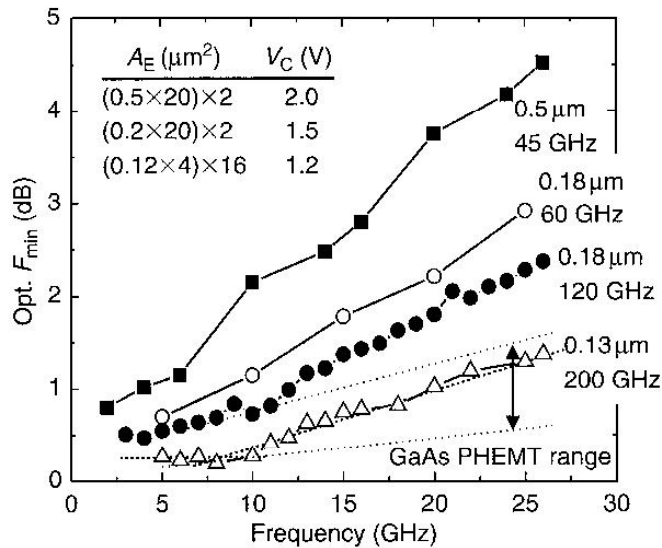


Figure 1.7: HBT optimized noise figure $Opt. F_{min}$ versus frequency for four SiGe HBT BiCMOS technologies, including three high performance variants at the 0.5-, 0.18-, and 0.13- μm nodes as well as a cost-reduced (and slightly higher breakdown voltage) variant at the 0.18- μm node. (Original figure was shown by D. Greenberg at IEEE MTT-S International Microwave Symposium, Fort Worth, 2004. The above figure is copied from [19])

1.6 Noise modeling considerations and methodology for SiGe HBTs

A good noise model should give an excellent fit for all the noise parameters. This calls for an accurate compact noise model for device noise. The noise models used for extrinsic parasitics are

well established and are sufficiently accurate for this purpose, so for this study the only concern is the intrinsic device noise modeling. As we are developing models for the wide sense steady (WSS) RF noise, the noise modeling can be completely based on small signal equivalent circuit due to the small signal nature of RF noise. Both semi-empirical and physical noise models are developed here. Emitter geometry scaling, especially emitter length scaling are examined for both models. MATLAB programs are used for small signal parameter extraction and noise calculation. The Verilog-A language is used to implement the new semi-empirical noise model in VBIC, a large signal BJT model applicable for circuit simulators such as Advanced Design System (ADS) supplied by Agilent Technologies.

1.7 Summary

This chapter describes the motivation for the research and the theoretical background for SiGe HBTs and RF noise modeling. In this dissertation, Chapter 2 gives the RF noise theory for SiGe HBTs. Chapter 3 explores the small signal extraction method for a small signal equivalent circuit including the input non-quasistatic effect. Chapter 4 describes the intrinsic noise source extraction technique and the new semi-empirical noise model developed based on the extraction results. Chapter 5 describes the new physical noise model developed for this study based on the improved electron and base hole noise models.

CHAPTER 2

RF NOISE THEORY FOR SiGe HBTs

This chapter opens with a description of two noise sources that are important for semiconductors, namely carrier velocity fluctuation and carrier population density fluctuation. Then two sets of base electron noise PSDs are presented without including the distributive effect, one of which is the solution for a new 1-D Langevin equation including finite exit velocity boundary condition for CB junction, the other is van Vliet's general solution for 3-D Langevin equation without including finite exit velocity boundary condition for CB junction. The 1-D solution is used to evaluate van Vliet's 3-D solution for the finite exit velocity effect. Both solutions are extended to include emitter hole noise. The crowding theory that deals with base distributive effect using segmentation method is then described. The compact noise model with three noise sources derived from the crowding theory by assuming uniform f_T across the whole EB junction is discussed in detail. Finally the disadvantages of previous noise models used in CAD tools and the literatures are reviewed, and new methods are proposed, with which to develop improved models.

2.1 RF noise sources

During the motions induced by external forces, carriers in semiconductors inevitably interact with lattice perturbations, impurities or other carriers, leading to observable terminal voltage or current variations from their ideal values. The noise measured at device terminals is referred to as *macroscopic noise*, while the spatially distributive fluctuations, such as carrier velocity, position, population density, are referred to as *microscopic noise*. To mathematically describe

the microscopic noise, two approaches can be followed, the microscopic and mesoscopic methods [21, 22]. The quantum mechanical microscopic method describes statistical carrier distributions within whole phase space or states based on Liouville / von Neumann's equations. Both the fluctuation-transportation equation and characterization of microscopic noise sources can be obtained in terms of Markov random processes. For example, a semi-classical k-space Boltzmann transport equation (BTE) with appropriate Langevin source has been derived [23–26], from which it is possible to obtain hydrodynamic or more simplified drift-diffusion models that include the microscopic noise sources. This approach is beyond the scope of this dissertation, and will not be further discussed. The *mesoscopic* approach deals with carrier fluctuations within coarse-grained time and space limits, e.g. $t \gg \tau_{cs}$ and $l \gg l_0$, where τ_{cs} is the expected collision time and l_0 is the expected free path distance. By satisfying such limits, the impact of the carrier's initial state vanishes. Different carriers may have the same statistical characterizations, so for carriers contained within a small mesoscopic volume, it is only necessary to study the statistical characterizations of one electron in order to know the statistical characterizations of the whole volume.

There are two main microscopic noise sources in semiconductor materials or devices. They are *generation-recombination (GR) noise*, which represents the carrier population density fluctuation due to transitions between bands and localized states (donors, traps, Shockley-Read-Hall centers, etc.), and *velocity fluctuation or diffusion noise*, which is associated with the Brownian motion of free carriers in the classical treatment or electron-phonon and electron-impurity scattering in the quantum treatment [21]. The underlying microscopic events are interband transitions for GR noise and intraband transitions for velocity fluctuation noise. To describe each of the two noise sources mesoscopically, two methods can be used: the coarse-grained mesoscopic Master equation (ME) approach and the Langevin approach.

The ME describes how the transition probability density evolves versus time for Markov processes as

$$\frac{\partial P(a, t|a')}{\partial t} = \int da'' [P(a'', t|a')W_{a''a'} - P(a, t|a')W_{aa''}], \quad (2.1)$$

where $P(a, t|a')$ is the probability density of state a at time t with initial state of a' at time zero, $W_{aa''}$ is the probability (density) per unit time of an instantaneous transition at time t from a to a'' , and similarly for $W_{a''a'}$. a and a' are the state vectors. (2.1) can be transformed into the Kramer-Moyal expansion. Often only the first and the second orders of such expansions are important. Truncating all higher orders (>2) yields the Fokker-Planck equation (FPE)

$$\frac{\partial P(a, t|a')}{\partial t} = - \sum_i \frac{\partial}{\partial a_i} [A_i(a)P] + \frac{1}{2} \sum_{ij} \frac{\partial}{\partial a_i \partial a_j} [B_{ij}(a)P], \quad (2.2)$$

where i and j denote different variables of state a , and A and B are the first and second order Fokker-Planck moments, explicitly

$$A_i(a) = \int (a'_i - a_i)W_{aa'} da', \quad B_{ij}(a) = \int (a'_i - a_i)(a'_j - a_j)W_{aa'} da'. \quad (2.3)$$

Moments A and B fully describe the stochastic process a , and hence determine the phenomenological noise source in the Langevin description, as shown below. From (2.2) and applying a Laplace transformation gives [21]

$$\frac{\partial \langle \Delta a(t) \rangle_{a'}}{\partial t} = -M \langle \Delta a(t) \rangle_{a'}, \quad M_{ij} = -\frac{\partial A_i(a')}{\partial a_j}. \quad (2.4)$$

This is the *phenomenological equation* that gives the average behavior of deviation for $a(t)$ from its initial state $a'(0)$. Such phenomenological equations may involve external or internal driving forces and sometimes friction forces. Theoretically, any higher order moment, such as covariances

and correlations, can be obtained in the same way as (2.4). Note that the Fourier transform of an autocorrelation gives the power spectrum density (PSD).

In the Langevin approach, (2.4) is written without the conditional averaging bracket by adding Langevin sources as

$$\frac{\partial \Delta a(t)}{\partial t} = -M \Delta a(t) + \xi(t). \quad (2.5)$$

Clearly $\xi(t)$ is used to *mimic* the random forces that produce the fluctuation of $a(t)$. Two necessary and sufficient requirements for $\xi(t)$ to provide the same first order and second order moments of $\Delta a(t)$, are [21]

$$\langle \xi(t) \rangle = 0, \quad \langle \xi(t) \xi(t') \rangle = B[a'(0)] \delta(t - t'). \quad (2.6)$$

From (2.6), the PSD of $\xi(t)$ can be obtained by performing a Fourier transformation as

$$S_{\xi, \xi} = 2B[a'(0)]. \quad (2.7)$$

The coefficient is 2, since single side band PSD is considered here (for measurement only positive frequencies are allowed). (2.7) explains the meaning of the Langevin force and how to obtain the PSD of such a force from the Master equation. The advantage of the Langevin approach is that the calculation of fluctuation-transportation can then be fully resolved based on familiar partial differential equations (PDEs).

The next section describes the PSD of the microscopic noise sources using these two methods. The emphasis here is on velocity fluctuation noise since it is the major noise source for modern SiGe HBTs with narrow base widths.

2.1.1 Velocity fluctuation noise

In the mesoscopic approach, carrier velocity fluctuations are modeled as the Brownian motion of a single particle that takes place in the corresponding band [21], i.e. electrons in the conduction band and holes in the valence band. The ground breaking work on the theory of Brownian motion was conducted by Einstein in 1905 in one of the classic papers he published that year [27] using a Fokker-Planck PDE he had derived, where the relation $\langle x^2 \rangle = 2Dt$ was first established. Another breakthrough was made in 1908 by Langevin using what is now called Langevin force method [28]. The Brownian motion theory was further elucidated by Uhlenbeck and Ornstein in 1930 [29], where the motion was treated using both the Langevin method and the Fokker-Planck method and the motion was proved to be Gaussian. A complete analysis of Brownian motion can be found in the 1943 classic paper by Chandrasekar [30]. The results of the PSD of velocity fluctuations, $S_{\delta v, \delta v}(\omega)$, are shown below using the ME/Fokker-Planck and Langevin methods respectively, after which the methods to establish the microscopic noise source representations for velocity fluctuations will be discussed.

Brownian motion, which is assumed to be a Markov stochastic process in phase space (\vec{r}, \vec{v}) , can be described by the Fokker-Planck equation (2.2). Further assuming that the scattering events are characterized by a collision time τ_{cs} , and that the carrier effective mass m^* is isotropic, the Fokker-Planck moment A and B can be derived as [29, 30]

$$A = \begin{bmatrix} \vec{v} \\ -\frac{1}{\tau_{cs}} \vec{v} \end{bmatrix}, \quad B = \begin{bmatrix} \textcircled{0} & \textcircled{0} \\ \textcircled{0} & \frac{2}{\tau_{cs}} \frac{kT}{m^*} \textcircled{\text{I}} \end{bmatrix}, \quad (2.8)$$

where $\textcircled{0}$ and $\textcircled{\text{I}}$ are rank-two zero and unitary tensors, respectively. The solution $P(\vec{r}, \vec{v}, t | \vec{r}_0, \vec{v}_0)$ for (2.2) and (2.8) can be found in [22, 30]. Using the obtained solution and the $\langle x^2 \rangle = 2Dt$

relation, the diffusion coefficient can be obtained as

$$D = \frac{\tau_{cs}kT}{m^*} = V_T\mu, \quad (2.9)$$

where μ is the carrier mobility defined as $e\tau_{cs}/m^*$. (2.9) states the Einstein relation. More accurate D and μ expressions can be derived from the Boltzmann transport equation. It shows that (2.9) holds only when carriers satisfy the Boltzmann statistics [31]. Therefore (2.9) is only valid for low field transport. As only the velocity of (\vec{r}, \vec{v}) is interested here, (2.2) is integrated through the whole \vec{r} space to obtain the equation for $P(\vec{v}, t | \vec{v}_0)$, briefly designated as P_v ,

$$\frac{\partial P_v}{\partial t} = \frac{1}{\tau_{cs}} \nabla_v \cdot (\vec{v} P_v) + \frac{1}{\tau_{cs}} \frac{kT}{m^*} \nabla_v^2 P_v. \quad (2.10)$$

The solution is [21, 30]

$$P(\vec{r}, \vec{v}, t | \vec{r}_0, \vec{v}_0) = \left[\frac{m^*}{2\pi kT(1 - e^{-2t/\tau_{cs}})} \right]^{1/2} \exp \left[-\frac{m^*}{2kT} \frac{|\vec{v} - \vec{v}_0 e^{-t/\tau_{cs}}|^2}{1 - e^{-2t/\tau_{cs}}} \right]. \quad (2.11)$$

The conditional mean velocity and variance can then be obtained as

$$\begin{aligned} \langle \vec{v}(t) \rangle_{\vec{v}_0} &= \vec{v}_0 e^{-t/\tau_{cs}}, \\ \langle \delta v(t)^2 \rangle_{\vec{v}_0} &\equiv \langle (\vec{v}(t) - \langle \vec{v}(t) \rangle_{\vec{v}_0})^2 \rangle_{\vec{v}_0} = \frac{kT}{m^*} (1 - e^{-2t/\tau_{cs}}) \mathbb{I}. \end{aligned} \quad (2.12)$$

(2.12) approaches Maxwell's equilibrium distribution when $t \gg \tau_{cs}$. From (2.11), the autocorrelation function of velocity can be obtained through integration as [22, 32]

$$R_{\delta v, \delta v}(t, t') = \left[-\frac{kT}{m^*} e^{-(t+t')/\tau_{cs}} + \frac{kT}{m^*} e^{-|t-t'|/\tau_{cs}} \right] \mathbb{I}. \quad (2.13)$$

By setting $t = t'$, (2.13) is correctly reduced to (2.12). Due to the coarse-grain procedure inherent in mesoscopic method, i.e. $t, t' \gg \tau_{cs}$, the stationary autocorrelation function is obtained from (2.13)

$$R_{\delta v, \delta v}(\tau) = \frac{1}{\tau_{cs}} D e^{-|\tau|/\tau_{cs}} \mathbb{I}, \quad (2.14)$$

where $\tau \equiv t - t'$ and D is given in (2.9). Now the single side band PSD of velocity fluctuation can be readily obtained from a Fourier transformation of (2.14) multiplied by two. The result is

$$S_{\delta v, \delta v}(\omega) = \frac{4D}{1 + \omega^2 \tau_{cs}^2} \mathbb{I}, \quad (2.15)$$

Since τ_{cs} is of the order of picoseconds, $S_{\delta v, \delta v}(\omega) \approx 4D \mathbb{I}$ is valid up to one hundred GHz.

For the Langevin method, two white-noise sources are introduced for \vec{r} and \vec{v} . The equations for the fluctuations of \vec{r} and \vec{v} are

$$\frac{d\delta\vec{r}}{dt} = \delta\vec{v} + \xi_r, \quad \frac{d\delta\vec{v}}{dt} = -\frac{1}{\tau_{cs}} \vec{v} + \xi_v. \quad (2.16)$$

ξ_v has a physical meaning of the *stochastic collision force*. According to (2.7), the PSD of ξ_r and ξ_v must obey

$$S_{\xi, \xi} = 2B = \begin{bmatrix} \textcircled{0} & \textcircled{0} \\ \textcircled{0} & \frac{4}{\tau_{cs}} \frac{kT}{m^*} \mathbb{I} \end{bmatrix}, \quad (2.17)$$

which means $S_{\xi_v, \xi_v}(\omega) = 4D/\tau_{cs}^2 \mathbb{I}$. Fourier transformation of (2.16) gives

$$\delta v = \frac{\tau_{cs}}{1 + j\omega\tau_{cs}} \xi_v. \quad (2.18)$$

The PSD of velocity fluctuation is therefore

$$S_{\delta v, \delta v}(\omega) = \frac{\tau_{cs}^2}{1 + \omega^2 \tau_{cs}^2} S_{\xi_v \xi_v} = \frac{4D}{1 + \omega^2 \tau_{cs}^2} \mathbb{I}, \quad (2.19)$$

which is consistent with the ME/Fokker-Planck result in (2.15). Since the noise power spectrum density is directly related to the diffusion coefficient, velocity fluctuation noise is also called *diffusion noise*.

The PSD of velocity fluctuation in (2.15) is true only for low electric field case. For modern SiGe HBTs, the built-in field in the base due to Ge gradient is quite strong. The high field impacts on diffusion, drift, and noise are no longer negligible. For example, the driving force for velocity saturation equation is approximated to be the gradient of carrier fermi level ∇E_f , instead of the gradient of electric potential $\nabla \phi$. (2.15) is a very rough approximation for the PSD of velocity fluctuation due to non-equilibrium effects. A self-consistent development of $S_{\delta v, \delta v}$ for high electric field can be followed from the full band Monte Carlo simulation under homogeneous bulk conditions [33]. In this work, (2.15) is used for simplicity.

Now the problem is to determine how the velocity fluctuation should be described as microscopic noise source. There are two possible kinds of descriptions, the physical *vector dipole current* noise source developed by Shockley [34] and the phenomenological *current density* Langevin noise source [35]. These are, of course, equivalent.

- Vector dipole current description

Due to velocity fluctuation $\delta \vec{v}$, a carrier labeled with m traveling between t_1 and t_2 has a disturbance from its ideal position as if the carrier is displaced by

$$\delta \vec{r}_m = \int_{t_1}^{t_2} \delta \vec{v}_m dt \approx \delta \vec{v}_m (t_2 - t_1).$$

as shown in Fig. 2.1. This means that *the carrier with charge e is taken from its ideal position and injected into a disturbed position*. The current produced by this procedure δI_m is $e/(t_2 - t_1)$.

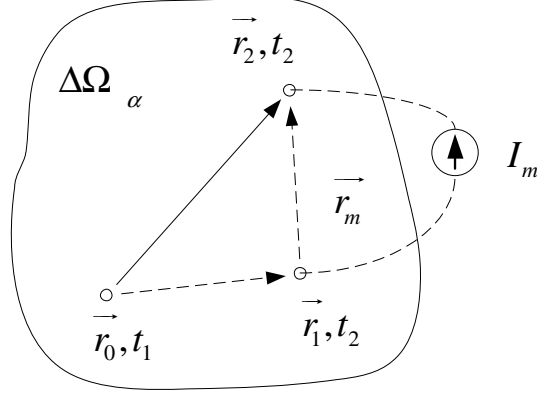


Figure 2.1: Illustration of vector dipole current.

Therefore

$$e\delta\vec{v}_m = e\frac{\delta\vec{r}_m}{t_2 - t_1} = \frac{e}{t_2 - t_1}\delta\vec{r}_m = \delta I_m\delta\vec{r}_m. \quad (2.20)$$

(2.20) clearly reveals that *velocity fluctuation has a physical meaning of vector dipole current*. Now at any given instant in a small volume satisfying the mesoscopic requirement,

$$(\Delta\Omega)_\alpha = \Delta x\Delta y\Delta z,$$

consider the total vector current dipole

$$\delta\mathfrak{P}_\alpha = e\sum_m\delta\vec{v}_m(t) = \delta I_\alpha\delta\vec{r}_\alpha. \quad (2.21)$$

$\delta\mathfrak{P}_\alpha$ includes all the noise generated within $(\Delta\Omega)_\alpha$. For the mesoscopic domain, fluctuations of all particles are independent and the same. The PSD of $\delta\mathfrak{P}_\alpha$ is thus directly obtained as

$$S_{\delta\mathfrak{P}_\alpha, \delta\mathfrak{P}_\alpha} = e^2 \sum_m S_{\delta v, \delta v} = \frac{4e^2 n D}{1 + \omega^2 \tau_{cs}^2} (\Delta\Omega)_\alpha, \quad (2.22)$$

where n is the carrier concentration at any position within the small volume $(\Delta\Omega)_\alpha$. For convenience, define the local noise source $K_\gamma(\vec{r}, \omega)$ as

$$K_\gamma(\vec{r}, \omega) \equiv \frac{4e^2 n D}{1 + \omega^2 \tau_c^2} \mathbb{I} \approx 4e^2 n D \mathbb{I}, \quad (2.23)$$

so that

$$S_{\delta\mathfrak{P}_\alpha, \delta\mathfrak{P}_\alpha} = K_\gamma(\vec{r}, \omega) (\Delta\Omega)_\alpha. \quad (2.24)$$

Such vector dipole current noise representation can be very easily used to calculate its contribution to the terminal macroscopic noise. For example, to examine the noise voltage at terminal N , δv_N , inject noise current δI_α at \vec{r}_1 , and subtract the same amount of noise current at \vec{r}_2 ($\delta\vec{r}_\alpha = \vec{r}_2 - \vec{r}_1$). Supposing the transfer impedance $Z_{N\alpha} \equiv \delta v_N / \delta I_\alpha$ is known for all positions within device, this gives

$$\delta v_N = [Z_{N\alpha}(\vec{r}_1) - Z_{N\alpha}(\vec{r}_2)] \delta I_\alpha = \nabla Z_{N\alpha} \cdot \delta\vec{r}_\alpha \delta I_\alpha = \nabla Z_{N\alpha} \cdot \delta\mathfrak{P}_\alpha. \quad (2.25)$$

Consequently, the total terminal noise voltage PSD can be obtained as

$$S_{v_N, v_N}(\omega) = \sum_\alpha S_{\delta v_N, \delta v_N}(r_\alpha, \omega) = \sum_\alpha |\nabla Z_{Nr}|^2 S_{\delta\mathfrak{P}_\alpha, \delta\mathfrak{P}_\alpha} = \int |\nabla Z_{Nr}|^2 K_\gamma(\vec{r}, \omega) d\Omega \quad (2.26)$$

This is the so-called *impedance field method* for noise calculation [34].

- Current density description

As the treatment of noise transport is based on the drift-diffusion (DD) model, the velocity fluctuation must be expressed in terms of current density fluctuations, denoted as $\vec{\gamma}(t)$ at a certain spatial position at time t , which can be directly inserted into the continuity equations. Again, considering a small volume $(\Delta\Omega)_\alpha$, the current density fluctuations induced by the m th carrier velocity fluctuations is represented by

$$\delta\vec{j}_m = \frac{e}{(\Delta\Omega)_\alpha} \delta\vec{v}_m. \quad (2.27)$$

The charge e is distributed uniformly within the whole small volume to obtain the charge density due to the m th carrier, since $\delta\vec{j}_m$ is the current density for any point within the small volume. Then

$$S_{\delta j_m, \delta j_m}(\omega) = \frac{e^2}{(\Delta\Omega)_\alpha^2} S_{\delta v_m, \delta v_m}(\omega). \quad (2.28)$$

Since the velocity fluctuations of different carriers within $(\Omega)_\alpha$ are uncorrelated, the total power spectrum of the current density fluctuations generated by $(\Omega)_\alpha$ is

$$S_\gamma(\omega) = \sum_m S_{\delta j_m, \delta j_m}(\omega) = n(\Delta\Omega)_\alpha S_{\delta j_m, \delta j_m}(\omega) = \frac{ne^2}{(\Delta\Omega)_\alpha} S_{\delta v, \delta v}(\omega) = \frac{K_\gamma(\vec{r}, \omega)}{(\Delta\Omega)_\alpha}. \quad (2.29)$$

Curiously, the current density fluctuation is the inverse of small volume. The problem will be clear after an examination of the averaged velocity for $(\Delta\Omega)_\alpha$

$$\delta\bar{v} = \frac{1}{N_\alpha} \sum_m \delta\vec{v}_m. \quad (2.30)$$

As

$$S_{\delta\bar{v},\delta\bar{v}} = \frac{1}{N_\alpha} \sum_m S_{\delta v_m, \delta v_m} = \frac{1}{n} \frac{S_{\delta v, \delta v}}{(\Delta\Omega)_\alpha}, \quad (2.31)$$

the averaged velocity fluctuation becomes stronger for smaller volume or fewer carriers. This is consistent with the intuitive concepts. As $\vec{\gamma} = \pm en\vec{v}$, this once again gives

$$S_\gamma(\omega) = e^2 n^2 S_{\delta\bar{v},\delta\bar{v}} = \frac{ne^2}{(\Delta\Omega)_\alpha} S_{\delta v, \delta v}(\omega) = \frac{K_\gamma(\vec{r}, \omega)}{(\Delta\Omega)_\alpha}. \quad (2.32)$$

The $S_\gamma(\omega)$ in (2.33) is the PSD of auto-correlation for the current density fluctuations $j(\vec{r})$ at any point \vec{r} within the small volume, i.e. $\langle j(\vec{r})j(\vec{r}) \rangle$. Since the current density fluctuation is uniform within the small volume, the current density fluctuations at any given two points within the same small volume, $j(\vec{r})$ and $j(\vec{r}')$, are correlated, and $\langle j(\vec{r})j(\vec{r}') \rangle = \langle j(\vec{r})j(\vec{r}) \rangle$. It can be assumed that the current density fluctuations at different small volumes are independent, that is, if \vec{r} is inside of $(\Delta\Omega)_\alpha$ while \vec{r}' is outside of \vec{r}' then $\langle j(\vec{r})j(\vec{r}') \rangle = 0$. Therefore the PSD of the current correlation at any given two points \vec{r} and \vec{r}' is

$$S_\gamma(\vec{r}, \vec{r}', \omega) = \frac{K_\gamma(\vec{r}, \omega)}{(\Delta\Omega)_{\vec{r}}} U_{(\Delta\Omega)_{\vec{r}}}(\vec{r}') = K_\gamma(\vec{r}, \omega) \frac{U_{(\Delta\Omega)_{\vec{r}}}(\vec{r}')}{(\Delta\Omega)_{\vec{r}}}, \quad (2.33)$$

where $(\Delta\Omega)_{\vec{r}}$ is the small volume containing \vec{r} , $U_{(\Delta\Omega)_{\vec{r}}}(\vec{r}')$ is a unit step function: it is one when \vec{r}' is inside of $(\Delta\Omega)_{\vec{r}}$ otherwise zero. (2.33) is already a Langevin source. However, it is not convenient to use due to the segmentation (divide the whole device into sufficient small volumes) needed before solving Langevin equations. Further, the size of the small volumes

should be infinite small to obtain exact results, which is the idea of integration. Note that

$$\lim_{(\Delta\Omega)_{\vec{r}} \rightarrow 0} \frac{U_{(\Delta\Omega)_{\vec{r}}}(\vec{r}')}{(\Delta\Omega)_{\vec{r}}} = \delta(\vec{r} - \vec{r}'), \quad (2.34)$$

the infinite small limit of (2.33) gives

$$S_{\gamma}(\vec{r}, \vec{r}', \omega) = K_{\gamma}(\vec{r}, \omega) \delta(\vec{r} - \vec{r}'), \quad (2.35)$$

where $K_{\gamma}(\vec{r}, \omega)$ is given in (2.23). (2.35) is the Langevin source for the diffusion noise in current density representation. Since this discussion is not confined to either electrons or holes, (2.35) is applicable to both carriers.

2.1.2 GR noise

GR noise induces population fluctuations within devices. Hence, the stochastic quantity *population changing rate* $\zeta(t)$ is a good description for such noise. $\zeta(t)$ has the physical meaning of *the injected current density fluctuation* at a given spatial position at time t . As with the velocity fluctuation noise, the power spectrum density of $\zeta(t)$, $S_{\zeta}(\vec{r}, \vec{r}', \omega)$, can be derived through either the ME/Fokker-Planck method or the Langevin method. Details can be found in [21, 22]. By considering only the band-to-band transitions and symmetric Shockley-Read-Hall (SRH) transitions, the result is

$$S_{\zeta}(\vec{r}, \vec{r}', \omega) = K_{\zeta}(\vec{r}, \omega) \delta(\vec{r} - \vec{r}'), \quad K_{\zeta}(\vec{r}, \omega) = \frac{2(n_0 + n)}{\tau}, \quad (2.36)$$

where τ is the carrier life time, n_0 is the DC equilibrium carrier concentration, n is the total carrier concentration, and $K_{\zeta}(\vec{r}, \omega)$ is the local noise source for population fluctuation. (2.36) is again applicable to both electrons and holes.

2.2 Electron noise of base region without distributive effect

This section first solves a 1-D Langevin equation to obtain the electron noise PSD for *base region*. The impact of finite exit velocity boundary condition at CB junction is considered. The general 3-D solution derived by van Vliet is then introduced although the finite exit velocity boundary condition is not considered. Finally, the van Vliet model is evaluated using the 1-D solution derived for the finite exit velocity condition. The CB SCR effect and base distributive effect are not considered in either case.

2.2.1 1-D solution

Assume a uniform base built-in field E induced by either the Ge gradient or the doping gradient, as shown in Fig. 2.2. E is measured using parameter η as in (1.1). The minus sign in (1.1)

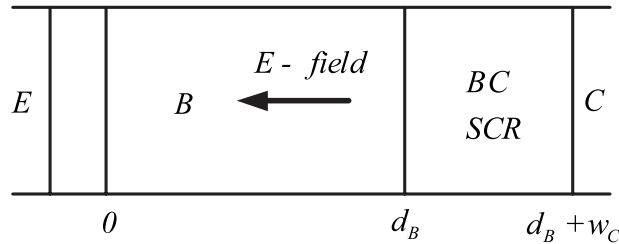


Figure 2.2: Illustration of base region with built-in electric field.

indicates an acceleration field for the electron from the emitter to the collector. The following are the parameters and variables used

- A_E – cross-sectional area of the 1-D device
- d_B – neutral base width.
- η – related to electrical field strength.
- μ_n – electron mobility.

- V_T – thermal voltage.
- D_n – electron diffusion coefficient, which is related to mobility through the Einstein relation, i.e. $D_n = V_T \mu_n$.
- v_{exit} – electron finite exit velocity at the CB junction, which is close to the electron saturation velocity.
- τ_n – electron life time.
- L_n – electron diffusion length, $L_n = \sqrt{D_n \tau_n}$.
- n_{00} – equilibrium electron concentration at the base beginning point ($x = 0$).

$$n_{00} = \frac{N_c N_v e^{\frac{-E_{g,si} + \Delta E_{g0}}{V_T}}}{N_A} = \frac{n_i^2 e^{\frac{\Delta E_{g0}}{V_T}}}{N_A}, \quad (2.37)$$

where N_A is the base doping concentration.

- n – electron concentration.
- n_0 – equilibrium electron concentration, given by

$$n_0 = n_{00} e^{\eta \frac{x}{d_B}}. \quad (2.38)$$

- Δn – excess electron concentration, $\Delta n = n - n_0$.
- $n_1 - \Delta n$ at $x = 0$.
- \tilde{n} – AC electron concentration.
- $\tilde{n}_1 - \tilde{n}$ at $x = 0$.

Solving the DC, AC continuity equations and Langevin equation gives the DC current, Y-parameters and the PSDs of the intrinsic base and collector noise currents. The electron finite exit velocity

boundary condition is forced at the end of the base for all three cases. The high field mobility model is used

$$\mu_n = \frac{\mu_{n0}}{\sqrt[\beta]{1 + \left(\frac{\mu_{n0}E}{v_{sat}}\right)^\beta}}.$$

Drift-Diffusion (DD) model is applied, i.e.

$$J_n = e\mu_n E n + eD_n \frac{d}{dx} n. \quad (2.39)$$

DC solution

V_{BE} is applied to the EB junction. Solving the continuity equation

$$D_n \frac{\partial^2}{\partial x^2} \Delta n + \mu_n E \frac{\partial}{\partial x} \Delta n - \frac{\Delta n}{\tau_n} = 0, \quad (2.40)$$

with the boundary conditions

$$\Delta n|_{x=0} \equiv n_1 = n_{00} \left(e^{\frac{V_{BE}}{V_T}} - 1 \right), \quad \Delta n|_{x=d_B} = -\frac{J_n|_{x=d_B}}{ev_{exit}},$$

gives the electron concentration and terminal current densities

$$\begin{aligned} \Delta n(x) &= \left(\frac{e^{\frac{\alpha_1 x}{d_B}}}{1 - \kappa^{-1} e^{2\theta}} + \frac{e^{\frac{\alpha_2 x}{d_B}}}{1 - \kappa e^{-2\theta}} \right) n_1, \\ J_C = J_n|_{x=d_B} &= -en_1 \frac{v_{exit}}{\delta - \alpha_2} \left(\frac{\alpha_1 - \alpha_2}{e^{-\alpha_2} - \kappa e^{-\alpha_1}} \right), \\ J_E = J_n|_{x=0} &= -en_1 \frac{v_{exit}}{\delta} \left(\frac{\eta}{2} + \theta \frac{e^{-\alpha_2} + \kappa e^{-\alpha_1}}{e^{-\alpha_2} - \kappa e^{-\alpha_1}} \right), \\ J_B &= J_C - J_E, \end{aligned} \quad (2.41)$$

where

$$\kappa = \frac{\alpha_1 - \delta}{\alpha_2 - \delta}, \quad \delta = \frac{v_{exit} d_B}{\mu_n V_T}, \quad \alpha_1 = \frac{\eta}{2} + \theta, \quad \alpha_2 = \frac{\eta}{2} - \theta, \quad \theta = \sqrt{\left(\frac{\eta}{2}\right)^2 + \left(\frac{d_B}{L_n}\right)^2}.$$

The base transit time can be obtained from (2.41) as

$$\tau_B = \frac{Q_B}{J_C} = \frac{d_B(\delta - \alpha_2)}{v_{exit}} \frac{\frac{1-e^{-\alpha_2}}{\alpha_2} - \frac{1-e^{-\alpha_1}}{\alpha_1} \kappa}{\alpha_1 - \alpha_2}, \quad (2.42)$$

With $v_{exit} \rightarrow \infty$ and $d_B \ll L_n$, (2.42) is reduced to the Kramer equation

$$\tau_{b0} = \left(\frac{1}{\eta} - \frac{1 - e^{-\eta}}{\eta^2} \right) \frac{d_B^2}{D_n}. \quad (2.43)$$

AC solution

Here a small signal \tilde{v}_{be} is applied to EB junction. Solving the AC continuity equation

$$D_n \frac{\partial^2 \tilde{n}}{\partial x^2} + \mu_n E \frac{\partial \tilde{n}}{\partial x} - \frac{\tilde{n}}{\tau_n} - j\omega \tilde{n} = 0, \quad (2.44)$$

with the boundary conditions

$$\tilde{n}|_{x=0} \equiv \tilde{n}_1 = \frac{n_{00}}{V_T} e^{\frac{V_{BE}}{V_T}} \tilde{v}_{be}, \quad \tilde{n}|_{x=d_B} = -\frac{\tilde{j}_n|_{x=d_B}}{e v_{exit}}.$$

leads to the electron concentration and terminal current densities as follows

$$\begin{aligned}
\tilde{n}(x) &= \left(\frac{e^{\frac{\tilde{\alpha}_1 x}{d_B}}}{1 - \tilde{\kappa}^{-1} e^{2\tilde{\theta}}} + \frac{e^{\frac{\tilde{\alpha}_2 x}{d_B}}}{1 - \tilde{\kappa} e^{-2\tilde{\theta}}} \right) \tilde{n}_1, \\
\tilde{j}_c &= \tilde{j}_n|_{x=d_B} = -e\tilde{n}_1 \frac{v_{exit}}{\delta - \tilde{\alpha}_2} \left(\frac{\tilde{\alpha}_1 - \tilde{\alpha}_2}{e^{-\tilde{\alpha}_2} - \tilde{\kappa} e^{-\tilde{\alpha}_1}} \right), \\
\tilde{j}_e &= \tilde{j}_n|_{x=0} = -e\tilde{n}_1 \frac{v_{exit}}{\delta} \left(\frac{\eta}{2} + \tilde{\theta} \frac{e^{-\tilde{\alpha}_2} + \tilde{\kappa} e^{-\tilde{\alpha}_1}}{e^{-\tilde{\alpha}_2} - \tilde{\kappa} e^{-\tilde{\alpha}_1}} \right), \\
\tilde{j}_b &= \tilde{j}_c - \tilde{j}_e,
\end{aligned} \tag{2.45}$$

where

$$\tilde{\kappa} = \frac{\tilde{\alpha}_1 - \delta}{\tilde{\alpha}_2 - \delta}, \quad \delta = \frac{v_{exit} d_B}{\mu_n V_T}, \quad \tilde{\alpha}_1 = \frac{\eta}{2} + \tilde{\theta}, \quad \tilde{\alpha}_2 = \frac{\eta}{2} - \tilde{\theta}, \quad \tilde{\theta} = \sqrt{\left(\frac{\eta}{2}\right)^2 + \left(\frac{d_B}{L_n}\right)^2 + j\omega \frac{d_B^2}{D_n}}. \tag{2.46}$$

From (2.45), the common-emitter Y-parameters for base region can be derived

$$\begin{aligned}
Y_{11,CE}^B &\equiv \frac{A_E \tilde{j}_b}{\tilde{v}_{be}} = A_E e^{\frac{n_{00}}{V_T}} e^{\frac{v_{BE}}{V_T}} \left[\frac{v_{exit}}{\delta} \left(\frac{\eta}{2} + \tilde{\theta} \frac{e^{-\tilde{\alpha}_2} + \tilde{\kappa} e^{-\tilde{\alpha}_1}}{e^{-\tilde{\alpha}_2} - \tilde{\kappa} e^{-\tilde{\alpha}_1}} \right) - \frac{v_{exit}}{\delta - \tilde{\alpha}_2} \left(\frac{\tilde{\alpha}_1 - \tilde{\alpha}_2}{e^{-\tilde{\alpha}_2} - \tilde{\kappa} e^{-\tilde{\alpha}_1}} \right) \right], \\
Y_{21,CE}^B &\equiv \frac{-A_E \tilde{j}_c}{\tilde{v}_{be}} = A_E e^{\frac{n_{00}}{V_T}} e^{\frac{v_{BE}}{V_T}} \frac{v_{sat}}{\delta - \tilde{\alpha}_2} \left(\frac{\tilde{\alpha}_1 - \tilde{\alpha}_2}{e^{-\tilde{\alpha}_2} - \tilde{\kappa} e^{-\tilde{\alpha}_1}} \right).
\end{aligned} \tag{2.47}$$

An equivalent circuit is needed to model these Y-parameters. The commonly used one is shown in Fig. 2.3 (b), where the $\Re(Y_{11})$ is frequency independent. The input network of Fig. 2.3 (b) is quasi-static (QS). Of particular interest for modeling the RF noise in the base current is the frequency dependence of the real part of the input admittance ($\Re(Y_{11})$) due to the base electron transport, as shown below. The frequency dependence of $\Re(Y_{11})$ for the base was first examined by Winkel [36] using (2.47). The results show that the base minority carrier charge responds to the base emitter voltage with an input delay time τ_{in}^b , after which the collector current at the end of base region responds to the stored base minority carrier charge with another delay time τ_{out}^b . τ_{in}^b represents the input non-quasistatic (NQS) effect and τ_{out}^b represents the output excess phase

delay. In an equivalent circuit, τ_{in}^b can be modeled by an input delay resistance r_d^b in series with EB junction diffusion capacitance C_{bed}^b as illustrated by Fig. 2.3 (a) [37,38]. $\tau_{in}^b = r_d^b C_{bed}^b$. Here the EB depletion capacitance C_{bej} is also included. As depletion capacitance is charged through majority carrier movement, C_{bej} does not experience an NQS delay, and should therefore be separated from C_{bed}^b . Note that $C_{bej} = 0$ and $C_{bed} = g_m \tau_{tr}^b$ for (2.47). τ_{tr}^b is the base transit time. τ_{out}^b can be included as a delay term in the transconductance. Fig. 2.4 shows the result of (2.47) together with

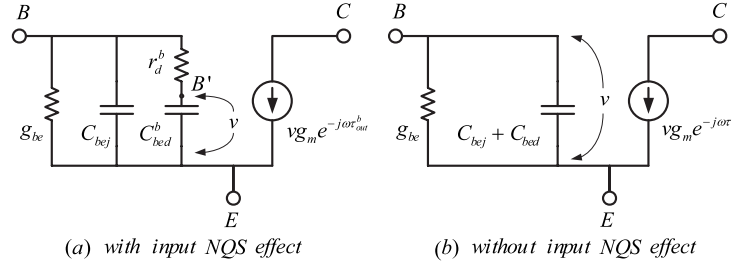


Figure 2.3: Equivalent circuit for intrinsic base of bipolar transistor without r_{bi} . (a) With NQS input. (b) With QS input.

the modeling result of Fig. 2.3 (a). Clearly, Fig. 2.3 (a) is accurate for frequencies up to f_T . The input NQS effect becomes more important at a given frequency for a larger Ge gradient device, as shown by $\Re(Y_{11})$ in Fig. 2.4. However, the modeling error due to using the QS equivalent circuit for a real device with a base resistance becomes smaller at high current levels for larger Ge gradient devices (see Section 2.4.2). Fig. 2.5 shows the extracted delay times for the base region. The solid line is the result of finite v_{exit} . The dashed line is the result of infinite v_{exit} . The finite v_{exit} will increase τ_{tr}^b by d_B/v_{exit} , as shown in Fig. 2.5 (a). Fig. 2.5 (b) shows the τ_{tr}^b normalized τ_{in}^b and τ_{out}^b . Finite v_{exit} has a subtle effect on the normalized value, and the finite v_{exit} does not change the importance of input and output NQS delay times. Note that the normalized NQS delay times increase versus η , with the result that τ_{in}^b and τ_{out}^b are weakly dependent on the Ge gradient. For

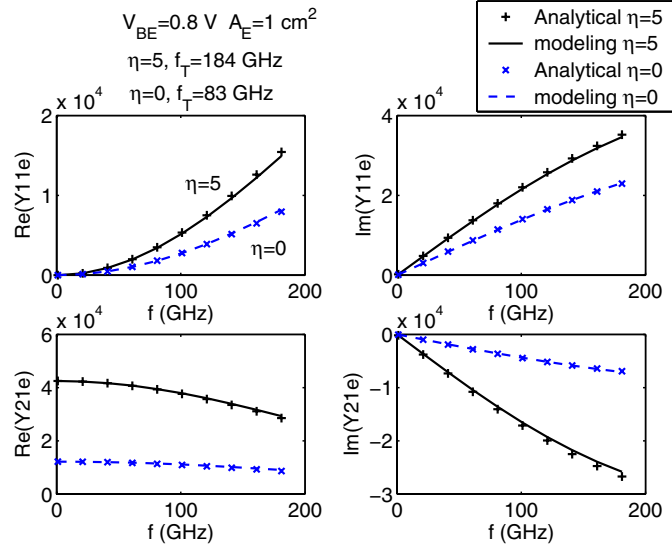


Figure 2.4: Y-parameter modeling result using equivalent circuit with NQS input. $\mu_0=270 \text{ cm}^2/\text{vs}^2$. $\tau_n = 1.54 \times 10^{-7} \text{ s}$. $n_{00} = 50/\text{cm}^3$. $T = 300 \text{ K}$. $d_B=45 \text{ nm}$. $V_{BE}=0.8 \text{ V}$. $v_{exit} = 1 \times 10^7 \text{ cm/s}$. $f_T = g_m/C_{bed}^b=184 \text{ GHz}$ for $\eta = 5$. $f_T = g_m/C_{bed}^b=83 \text{ GHz}$ for $\eta = 0$. $A_E=1 \text{ cm}^2$.

input NQS delay resistance,

$$\begin{aligned}
 r_d^b &= \frac{\tau_{in}^b}{C_{bed}^b} = \frac{1}{g_m} \frac{\tau_{in}^b}{\tau_{tr}^b} \approx \frac{1}{W_E L_E J_c / V_T} \frac{\tau_{in}^b}{\tau_{tr}^b} \approx \frac{1}{W_E L_E n_1 / (d_B V_T)} \frac{\tau_{in}^b}{\tau_{tr}^b} \\
 &\approx \frac{1}{W_E L_E n_{00} e^{V_{BE}/V_T} / (d_B V_T)} \frac{\tau_{in}^b}{\tau_{tr}^b} = \frac{d_B V_T}{W_E L_E n_{00} e^{V_{BE}/V_T}} \frac{\tau_{in}^b}{\tau_{tr}^b} \\
 &= \left(\frac{d_B}{W_E L_E} \right) \left(\frac{n_i^2}{N_A} \right) \left(\frac{\tau_{in}^b}{\tau_{tr}^b} \right) e^{\Delta E_{g0}/V_T} V_T e^{-V_{BE}/V_T}. \tag{2.48}
 \end{aligned}$$

The impacts of base geometry, base doping and bias on r_d^b are clear from (2.48). However the η and finite v_{exit} impacts are not clear due to the approximations made. Fig. 2.6 shows the input NQS delay resistance r_d^b versus η at $V_{BE}=0.8 \text{ V}$. Both the finite and infinite v_{exit} are shown. By increasing the Ge gradient, r_d^b is reduced. A finite CB exit velocity increases r_d^b . This is discussed further in Section 2.4.2.

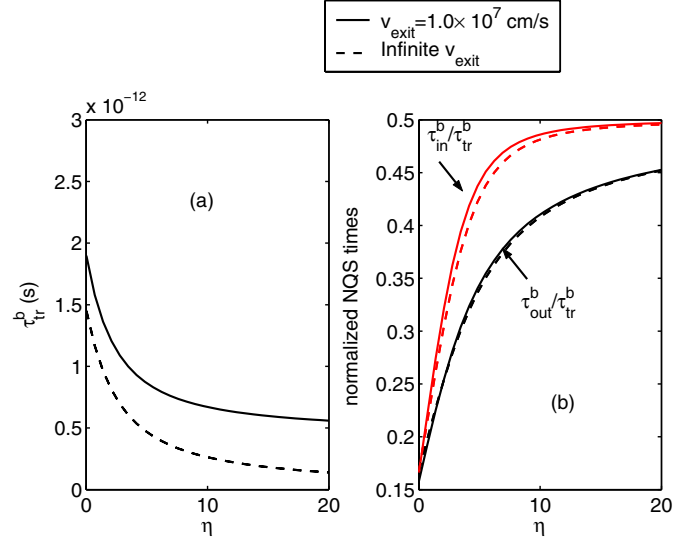


Figure 2.5: Delay times of base region. $\mu_0=270$ cm/vs². $\tau_n = 1.54 \times 10^{-7}$ s. $n_{00} = 50/cm^3$. $T = 300K$. $d_B=45$ nm. $A_E=1$ cm².

Noise solution

The 1-D Langevin equation for the base electron noise is

$$-D_n \frac{\partial^2 \tilde{n}}{\partial x^2} - \mu_n E \frac{\partial \tilde{n}}{\partial x} + \frac{\tilde{n}}{\tau_n} + j\omega \tilde{n} = \xi(x, \omega), \quad (2.49)$$

where

$$\xi(x, \omega) = \zeta(x, \omega) + \frac{1}{e} \frac{\partial}{\partial x} \gamma(x, \omega). \quad (2.50)$$

The Langevin noise sources $\xi(\omega)$ is the sum of the GR noise $\zeta(\omega)$ and the gradient of diffusion noise $\gamma(\omega)$, which have been described in Section 2.1. The boundary condition for (2.49) is

$$\tilde{n}|_{x=0} = 0, \tilde{n}|_{x=d_B} = -\frac{\tilde{j}_n}{ev_{exit}}. \quad (2.51)$$

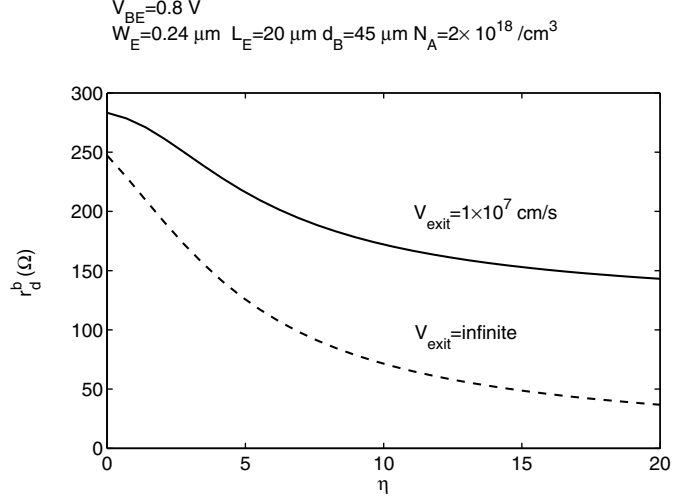


Figure 2.6: Input NQS delay resistance r_d^b versus η at $V_{BE}=0.8 \text{ V}$. $\mu_0=270 \text{ cm/vs}^2$. $\tau_n = 1.54 \times 10^{-7} \text{ s}$. $n_{00} = 50 / \text{cm}^3$ ($N_A = 2 \times 10^{18} / \text{cm}^3$). $T = 300 \text{ K}$. $d_B=45 \text{ nm}$. $W_E=0.24 \text{ } \mu\text{m}$. $L_E=20 \text{ } \mu\text{m}$. $A_E=1 \text{ cm}^2$.

To solve (2.49)-(2.50), the Green function method [22] is used. First, we define a carrier density Green function $G_n(x, x')$, which satisfies

$$\begin{aligned}
 -D_n \frac{\partial^2}{\partial x^2} G_n(x, x') - \mu_n E \frac{\partial}{\partial x} G_n(x, x') + \frac{G_n(x, x')}{\tau_n} + j\omega G_n(x, x') &= \delta(x - x'), \quad (2.52) \\
 G_n(x, x') = 0|_{x=0}, \quad G_n(x, x') &= -\frac{\tilde{j}_n(x)}{e v_{\text{exit}}}|_{x=d_B}, \quad x \in [0, d_B], \quad x' \in (0, d_B).
 \end{aligned}$$

Clearly $G_n(x, x')$ is the electron density change at position x responding to the unity point carrier flux density injection at position x' , The total carrier density fluctuation \tilde{n} for (2.49) can then be obtained as

$$\tilde{n}(x) = \int_0^{d_B} G_n(x, x') \xi(x', \omega) dx'. \quad (2.53)$$

However, the PSD for terminal current instead of carrier density is needed. To provide this, operate $e\mu E + eD_n \frac{d}{dx}$ on both sides of (2.53)

$$\tilde{j}_n(x) = \int_0^{d_B} \left(e\mu E + eD_n \frac{d}{dx} \right) G_n(x, x') \xi(x', \omega) dx'. \quad (2.54)$$

For convenience, we define terminal carrier flux density (current density divided by $-e$) Green functions (scalar)

$$G_e(x') = \left(\mu E + D_n \frac{d}{dx} \right) G_n(x, x')|_{x=0}, \quad (2.55)$$

$$G_c(x') = - \left(\mu E + D_n \frac{d}{dx} \right) G_n(x, x')|_{x=d_B}. \quad (2.56)$$

$G_e(x')$ and $G_c(x')$ are thus the emitter and collector *outflow* carrier flux densities responding to the unity point carrier flux density injection at position x' , respectively. The base terminal *outflow* carrier flux density responding to the unity point carrier flux density injection at position x' , denoted as $G_b(x')$ can be obtained directly from the quasi-neutral condition, that is

$$G_b(x') = 1 - G_c(x') - G_e(x'). \quad (2.57)$$

The terminal *inflow* noise current density fluctuations are

$$\tilde{j}_e = e \int_0^{d_B} G_e(x') \xi(x', \omega) dx', \quad \tilde{j}_c = e \int_0^{d_B} G_c(x') \xi(x', \omega) dx', \quad \tilde{j}_b = e \int_0^{d_B} G_b(x') \xi(x', \omega) dx', \quad (2.58)$$

The PSD for the correlation between the noise current densities of terminal α and β ($\alpha, \beta = e, c, b$) can be obtained via the following integration

$$\begin{aligned}
S_{j_\alpha j_\beta^*}(\omega) &\equiv \langle \tilde{j}_\alpha \tilde{j}_\beta^* \rangle = e^2 \int_0^{d_B} \int_0^{d_B} G_\alpha(x) \langle \xi(x) \xi(x') \rangle G_\beta^*(x') dx dx' \\
&= e^2 \int_0^{d_B} \int_0^{d_B} G_\alpha(x) \langle \zeta(x) \zeta(x') \rangle G_\beta^*(x') dx dx' \\
&\quad + \int_0^{d_B} \int_0^{d_B} G_\alpha(x) \frac{\partial}{\partial x} \frac{\partial}{\partial x'} \langle \gamma(x) \gamma(x') \rangle G_\beta^*(x') dx dx' \\
&\approx e^2 \int_0^{d_B} \int_0^{d_B} G_\alpha(x) \langle \zeta(x) \zeta(x') \rangle G_\beta^*(x') dx dx' \\
&\quad + \int_0^{d_B} \int_0^{d_B} \frac{\partial G_\alpha(x)}{\partial x} \langle \gamma(x) \gamma(x') \rangle \frac{\partial G_\beta^*(x')}{\partial x'} dx dx' \\
&= e^2 \int_0^{d_B} \int_0^{d_B} G_\alpha(x) K_\zeta(x, \omega) \delta(x - x') G_\beta^*(x') dx dx' \\
&\quad + \int_0^{d_B} \int_0^{d_B} \frac{\partial G_\alpha(x)}{\partial x} K_\gamma(x, \omega) \delta(x - x') \frac{\partial G_\beta^*(x')}{\partial x'} dx dx' \\
&= e^2 \int_0^{d_B} G_\alpha(x') K_\zeta(x', \omega) G_\beta(x')^* dx' \\
&\quad + \int_0^{d_B} \vec{G}_\alpha(x') K_\gamma(x', \omega) \vec{G}_\beta(x')^* dx', \tag{2.59}
\end{aligned}$$

where $\vec{G}_{\alpha, \beta}(x')$ are vector Green functions:

$$\vec{G}_e(x') \equiv \frac{\partial}{\partial x'} G_e(x'), \quad \vec{G}_c(x') \equiv \frac{\partial}{\partial x'} G_c(x'), \quad \vec{G}_b(x') \equiv \frac{\partial}{\partial x'} G_b(x') = -\vec{G}_e(x') - \vec{G}_c(x'). \tag{2.60}$$

The approximation made for the third step in (2.59) is the neglecting of two complex surface integrations when using Gauss theorem when the finite exit velocity boundary condition is not considered. (2.59) shows that the scalar Green functions should be used for GR noise and the vector Green functions should be used for diffusion noise.

Now to solve $G_n(x, x')$, a unity current pulse is inserted at position x' as shown in Fig. 2.7.

Note $\delta i = 1$. The boundary condition in (2.51) changes to

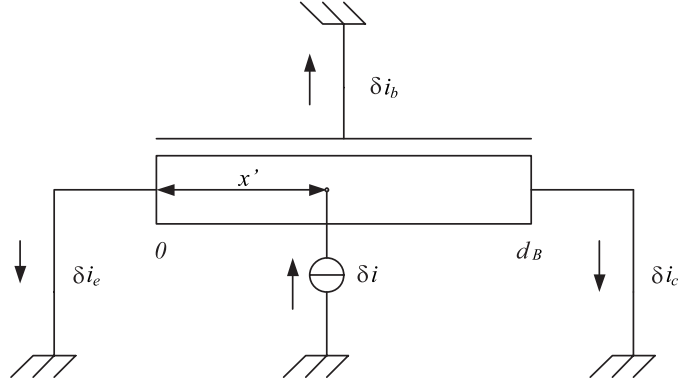


Figure 2.7: Setup for solving Langevin equation.

$$\begin{aligned}
 G_n(x, x')|_{x=0} &= 0, & G_n(x, x')|_{x=x'_-} &= G_n(x, x')|_{x=x'_+}, \\
 \frac{\partial G_n(x, x')}{\partial x}|_{x=x'_+} - \frac{\partial G_n(x, x')}{\partial x}|_{x=x'_-} &= \frac{\delta i}{D_n}, & G_n(x, x')|_{x=d_B} &= -\frac{\tilde{J}_n}{ev_{exit}}.
 \end{aligned} \tag{2.61}$$

The third condition in (2.61) can be obtained by integrating (2.49) over the area around x' . The solutions for (2.49) and (2.61) are

$$G_n(x, x') = \begin{cases} \frac{d_B}{2D_n} \frac{\left(e^{-\frac{\tilde{\alpha}_1 x'}{d_B}} - \tilde{\kappa} e^{-2\tilde{\theta}} e^{-\frac{\tilde{\alpha}_2 x'}{d_B}} \right) \left(-e^{\frac{\tilde{\alpha}_1 x}{d_B}} + e^{\frac{\tilde{\alpha}_2 x}{d_B}} \right)}{\tilde{\theta}(1 - \tilde{\kappa} e^{-2\tilde{\theta}})}, & \text{if } x \in [0, x']; \\ \frac{d_B}{2D_n} \frac{\left(e^{\frac{\tilde{\alpha}_2 x}{d_B}} - \tilde{\kappa} e^{-2\tilde{\theta}} e^{\frac{\tilde{\alpha}_1 x}{d_B}} \right) \left(e^{-\frac{\tilde{\alpha}_1 x'}{d_B}} - e^{-\frac{\tilde{\alpha}_2 x'}{d_B}} \right)}{\tilde{\theta}(1 - \tilde{\kappa} e^{-2\tilde{\theta}})}, & \text{if } x \in (x', d_B], \end{cases} \tag{2.62}$$

where $\tilde{\alpha}_1$, $\tilde{\alpha}_2$, $\tilde{\kappa}$ and $\tilde{\theta}$ are given in 2.46.

With $G_n(x, x')$, the scalar and vector Green functions can be calculated from (2.55), (2.56), (2.57) and (2.60). The results are

$$\begin{aligned}
G_e(x') &= \frac{e^{-\frac{\tilde{\alpha}_1 x'}{d_B}} - \tilde{\kappa} e^{-2\tilde{\theta}} e^{-\frac{\tilde{\alpha}_2 x'}{d_B}}}{1 - \tilde{\kappa} e^{-2\tilde{\theta}}}, \\
G_c(x') &= \frac{e^{-\frac{\tilde{\alpha}_1 x'}{d_B}} - e^{-\frac{\tilde{\alpha}_2 x'}{d_B}}}{1 - \tilde{\kappa} e^{-2\tilde{\theta}}} \frac{(\tilde{\alpha}_1 - \tilde{\kappa} \tilde{\alpha}_2) e^{\tilde{\alpha}_2}}{\tilde{\alpha}_2 - \tilde{\alpha}_1}, \\
G_b(x') &= 1 - G_e(x') - G_c(x'), \\
\vec{G}_e(x') &= -\frac{\tilde{\alpha}_1 e^{-\frac{\tilde{\alpha}_1 x'}{d_B}} - \tilde{\alpha}_2 \tilde{\kappa} e^{-2\tilde{\theta}} e^{-\frac{\tilde{\alpha}_2 x'}{d_B}}}{d_B(1 - \tilde{\kappa} e^{-2\tilde{\theta}})} \hat{x}, \\
\vec{G}_c(x') &= -\frac{\tilde{\alpha}_1 e^{-\frac{\tilde{\alpha}_1 x'}{d_B}} - \tilde{\alpha}_2 e^{-\frac{\tilde{\alpha}_2 x'}{d_B}}}{d_B(1 - \tilde{\kappa} e^{-2\tilde{\theta}})} \frac{(\tilde{\alpha}_1 - \tilde{\kappa} \tilde{\alpha}_2) e^{\tilde{\alpha}_2}}{\tilde{\alpha}_2 - \tilde{\alpha}_1} \hat{x}, \\
\vec{G}_b(x') &= -\vec{G}_e(x') - \vec{G}_c(x').
\end{aligned} \tag{2.63}$$

Figs. 2.8 and 2.9 show the scalar Green functions and vector Green functions, respectively, plotted versus base position. For the solid lines, $v_{exit} = 1 \times 10^7$ cm/s, and for the dashed lines, $v_{exit} \rightarrow \infty$.

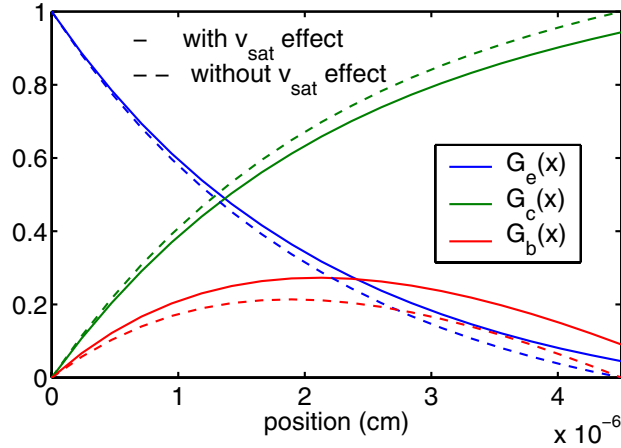


Figure 2.8: Scalar Green functions.

Given the Green functions in (2.63) and DC electron concentration in (2.41), all the noise PSDs can be obtained by integrating (2.59). Since the diffusion noise dominates for the base

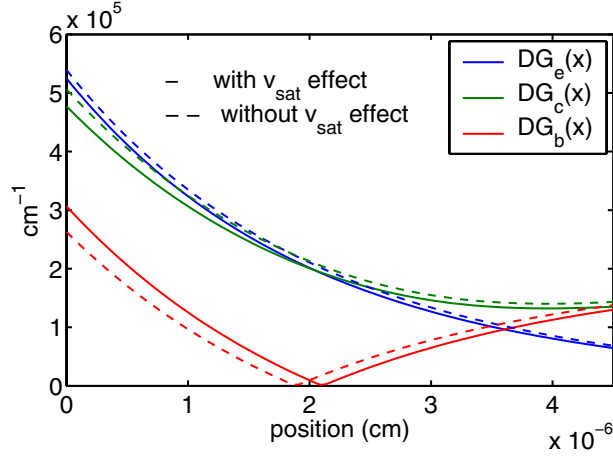


Figure 2.9: Vector Green functions.

region of SiGe HBT, only the analytical results for diffusion noise are given here:

$$\begin{aligned}
S_{ib}^B \equiv S_{ibib^*}^B = A_E \Big[& |A + C|^2 \bar{K} \frac{d_B}{-\tilde{\alpha}_1 - \tilde{\alpha}_1^* + \alpha_1} \left(e^{-\tilde{\alpha}_1 - \tilde{\alpha}_1^* + \alpha_1} - 1 \right) \\
& + |B + D|^2 \bar{K} \frac{d_B}{-\tilde{\alpha}_2 - \tilde{\alpha}_2^* + \alpha_1} \left(e^{-\tilde{\alpha}_2 - \tilde{\alpha}_2^* + \alpha_1} - 1 \right) \\
& + (A^* + C^*)(B + D) \bar{K} \frac{d_B}{-\tilde{\alpha}_1^* - \tilde{\alpha}_2 + \alpha_1} \left(e^{-\tilde{\alpha}_1^* - \tilde{\alpha}_2 + \alpha_1} - 1 \right) \\
& + (A + C)(B^* + D^*) \bar{K} \frac{d_B}{-\tilde{\alpha}_1 - \tilde{\alpha}_2^* + \alpha_1} \left(e^{-\tilde{\alpha}_1 - \tilde{\alpha}_2^* + \alpha_1} - 1 \right) \\
& + \text{first 4 lines, substitute } \alpha_1 \rightarrow \alpha_2 \text{ and } \bar{K} \rightarrow \bar{L} \\
& + \text{first 4 lines, substitute } \alpha_1 \rightarrow \eta \text{ and } \bar{K} \rightarrow \overline{KL} \Big], \quad (2.64)
\end{aligned}$$

$$\begin{aligned}
S_{icib}^B = A_E & \left[-C(A^* + C^*)\bar{K} \frac{d_B}{-\tilde{\alpha}_1 - \tilde{\alpha}_1^* + \alpha_1} \left(e^{-\tilde{\alpha}_1 - \tilde{\alpha}_1^* + \alpha_1} - 1 \right) \right. \\
& - D(B^* + D^*)\bar{K} \frac{d_B}{-\tilde{\alpha}_2 - \tilde{\alpha}_2^* + \alpha_1} \left(e^{-\tilde{\alpha}_2 - \tilde{\alpha}_2^* + \alpha_1} - 1 \right) \\
& - D(A^* + C^*)\bar{K} \frac{d_B}{-\tilde{\alpha}_1^* - \tilde{\alpha}_2 + \alpha_1} \left(e^{-\tilde{\alpha}_1^* - \tilde{\alpha}_2 + \alpha_1} - 1 \right) \\
& - C(B^* + D^*)\bar{K} \frac{d_B}{-\tilde{\alpha}_1 - \tilde{\alpha}_2^* + \alpha_1} \left(e^{-\tilde{\alpha}_1 - \tilde{\alpha}_2^* + \alpha_1} - 1 \right) \\
& + \text{first 4 lines, substitute } \alpha_1 \rightarrow \alpha_2 \text{ and } \bar{K} \rightarrow \bar{L} \\
& \left. + \text{first 4 lines, substitute } \alpha_1 \rightarrow \eta \text{ and } \bar{K} \rightarrow \overline{KL} \right], \tag{2.65}
\end{aligned}$$

$$\begin{aligned}
S_{ic}^B \equiv S_{icic}^B = A_E & \left[|C|^2 \bar{K} \frac{d_B}{-\tilde{\alpha}_1 - \tilde{\alpha}_1^* + \alpha_1} \left(e^{-\tilde{\alpha}_1 - \tilde{\alpha}_1^* + \alpha_1} - 1 \right) \right. \\
& + |D|^2 \bar{K} \frac{d_B}{-\tilde{\alpha}_2 - \tilde{\alpha}_2^* + \alpha_1} \left(e^{-\tilde{\alpha}_2 - \tilde{\alpha}_2^* + \alpha_1} - 1 \right) \\
& + C^* D \bar{K} \frac{d_B}{-\tilde{\alpha}_1^* - \tilde{\alpha}_2 + \alpha_1} \left(e^{-\tilde{\alpha}_1^* - \tilde{\alpha}_2 + \alpha_1} - 1 \right) \\
& + C D^* \bar{K} \frac{d_B}{-\tilde{\alpha}_1 - \tilde{\alpha}_2^* + \alpha_1} \left(e^{-\tilde{\alpha}_1 - \tilde{\alpha}_2^* + \alpha_1} - 1 \right) \\
& + \text{first 4 lines, substitute } \alpha_1 \rightarrow \alpha_2 \text{ and } \bar{K} \rightarrow \bar{L} \\
& \left. + \text{first 4 lines, substitute } \alpha_1 \rightarrow \eta \text{ and } \bar{K} \rightarrow \overline{KL} \right], \tag{2.66}
\end{aligned}$$

where

$$\begin{aligned}
A &= -\frac{\tilde{\alpha}_1}{d_B (1 - \tilde{\kappa} e^{-2\tilde{\theta}})}, \quad B = \frac{\tilde{\kappa} e^{-2\tilde{\theta}} \tilde{\alpha}_2}{d_B (1 - \tilde{\kappa} e^{-2\tilde{\theta}})}, \quad C = A \frac{(\tilde{\alpha}_1 - \tilde{\kappa} \tilde{\alpha}_2) e^{\tilde{\alpha}_2}}{\tilde{\alpha}_2 - \tilde{\alpha}_1}, \quad D = -C \frac{\tilde{\alpha}_2}{\tilde{\alpha}_1}, \\
\bar{K} &= \frac{4q^2 D_n n_{00} e^{\frac{V_{BE}}{V_T}}}{1 - \kappa^{-1} e^{2\theta}}, \quad \bar{L} = \frac{4q^2 D_n n_{00} e^{\frac{V_{BE}}{V_T}}}{1 - \kappa e^{-2\theta}}, \quad \overline{KL} = 4q^2 D_n n_{00}.
\end{aligned}$$

$$\alpha_1 = \tilde{\alpha}_1|_{\omega=0}, \quad \alpha_2 = \tilde{\alpha}_2|_{\omega=0}, \quad \kappa = \tilde{\kappa}|_{\omega=0}.$$

The last two lines in each PSD represent eight terms that are obtained by a parameter substitution procedure performed on the first four lines. The velocity saturation boundary condition is involved through parameter κ . $\kappa = 1$ if such a condition is neglected.

2.2.2 General 3-D solution by van Vliet

The 3-D Langevin equation for base electron noise is solved by van Vliet using Green's function method in [39]. The adiabatic (homogeneous) boundary condition, i.e. $\tilde{n}=0$ or zero electron density fluctuation, is used for both ends of the base region. The built-in field can be position dependent. It is important to note that the base distributive effect is not considered in van Vliet's derivation in spite of the 3-D analysis because the AC bias voltage for the whole EB junction is assumed to be uniform. In the derivation, the Y-parameters are expressed by Green's functions in *linear* fashion using the extended Green theorem. The power spectrum densities of noise are initially *quadratic* in Green's functions. In order to make the connection between noise PSD and the Y-parameter, it is convenient to transform the noise PSD into a result whose main part is linear in the Green's functions. This is accomplished using the Λ theorem in [40]. Finally the base electron noises are related to the Y-parameters of the base region. The detailed derivation is given in Appendix H. The original results are in common-base configuration but can be readily transformed into common-emitter configuration. The results are

$$\begin{aligned}
S_{ib}^B &= 4kT\Re(Y_{11}^B) - 2qI_b^B, \\
S_{ic}^B &= 4kT\Re(Y_{22}^B) + 2qI_c, \\
S_{icib^*}^B &= 2kT(Y_{21}^B + Y_{12}^{B*} - g_m),
\end{aligned} \tag{2.67}$$

where I_b^B is the DC base recombination current. Here, the frequency dependence of S_{ib}^B and S_{ic}^B , as well as their correlation $S_{icib^*}^B$, are taken into account through the frequency dependence of the Y-parameters of base Y^B . For SiGe HBTs, or modern transistors, I_b^B is negligible. Instead, the base

current due to hole injection into the emitter, I_b^E , dominates I_b . Also van Vliet's derivation failed to consider electron transport in the CB SCR, which is noticeable for aggressively scaled HBTs. This is because the van Vliet model was derived for early transistors in which the base current is dominated by base recombination. The 3-D Langevin equation was solved only for base minority carriers, which in the case of SiGe HBTs is the electrons. Therefore, the base DC recombination current and Y-parameters of base region should be used in (2.67). In practice, however, the total base current I_b ($I_b^B + I_b^E$) and the Y-parameters of whole transistor are brutally used in (2.67), and the results are recognized as the noise of whole transistor, which is not justified. These issues will be discussed in detail in Chapter 5.

2.2.3 Evaluation of van Vliet solution for finite exit velocity boundary condition

Using the 1-D Langevin equation solution derived above, for cases where the finite exit velocity is not included in the boundary conditions, the van Vliet model gives the base electron noise exactly, as expected. When such boundary condition is applied, however, the van Vliet model deviates from the analytical results when the base width becomes narrow. Fig. 2.10 shows the wide base case ($d_B=100$ nm), where the van Vliet model is consistent with the 1-D solution. Fig. 2.11 shows the narrow base case ($d_B=20$ nm). The van Vliet model clearly overestimates S_{ib} and $|\Re(S_{icib^*})|$ while underestimating $|\Im(S_{icib^*})|$.

However, with a strong base built-in field, typically the case in graded SiGe HBTs, the deviation is significantly reduced, as shown in Fig. 2.12, where $\eta = 5.4$. A careful inspection of the solution process does not yield an intuitive explanation for this observation, but calculations show that this is generally true for all practical values of built-in field found in modern SiGe HBTs with graded bases. Therefore, it is reasonable to continue to use the van Vliet model to describe the relationship between noise and Y-parameters of the intrinsic base for graded SiGe HBTs. This is the starting point for the analysis of the CB SCR effect given in Chapter 5.

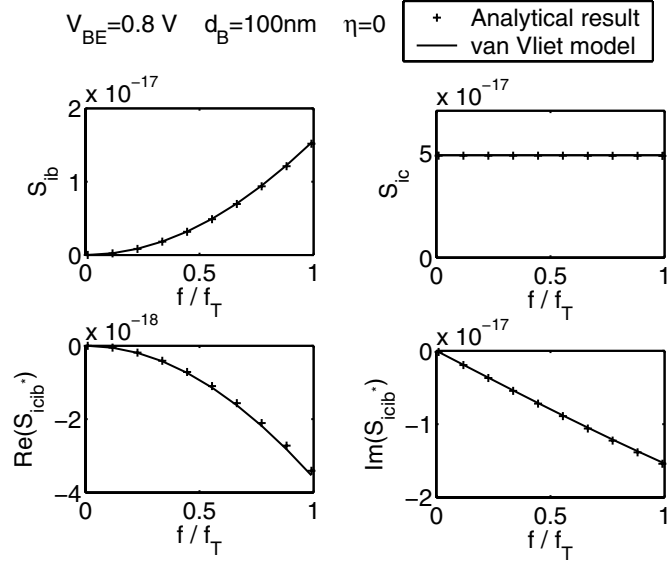


Figure 2.10: Evaluation of van Vliet model for base region noise under $d_B = 100\text{ nm}$, $\eta = 5.4$ ($|E|=70.2\text{ kV/cm}$), $V_{BE}=0.8\text{ V}$, where “ f_T ” $\equiv g_m/C_{be}=698\text{ GHz}$. $A_E=1\text{ cm}^2$.

2.3 Extension to including emitter hole noise

For modern transistors, the base current due to hole injection into the emitter, I_b^E , dominates the base current. At low frequency, the PSD of i_b^E should be $2qI_b^E$ to first order, which is much larger than the PSD of base recombination current $2qI_b^B$. Therefore it is important to include base hole noise.

2.3.1 3-D van Vliet model

To obtain the emitter hole noise induced base noise current i_b^E , and denote its PSD as S_{ib}^E , it is necessary to solve a 3-D Langevin equation for emitter minority carriers (holes here as NPN HBTs are of interest) with a boundary condition $\Delta p = 0$ at both the emitter contact and the neutral to depletion boundary of the EB junction. Δp is the hole density fluctuation. $\Delta p = 0$ at the emitter contact as infinite surface recombination velocity is assumed. $\Delta p = 0$ at the neutral to depletion boundary of the EB junction, as the same adiabatic boundary condition used in [39] is assumed.

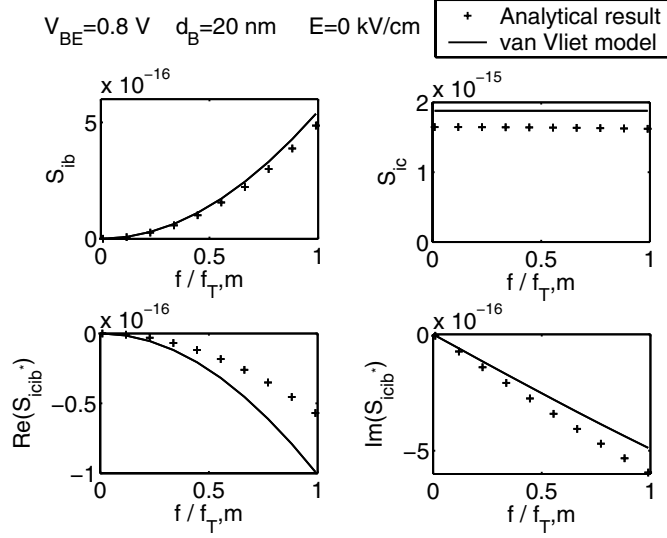


Figure 2.11: Evaluation of van Vliet model for base region noise under $d_B = 20\text{nm}$, $\eta = 5.4$ ($|E|=0$ kV/cm), $V_{BE}=0.8\text{V}$, where “ f_T ” $\equiv g_m/C_{be}=698$ GHz. $A_E=1\text{ cm}^2$.

The solution can be obtained following van Vliet’s derivation for base minority carrier noise [39]. The Langevin equation for minority holes in the emitter of NPN HBT solved here is exactly the same Langevin equation for minority holes in the base of PNP transistor solved in [39] with the same adiabatic condition $\Delta p = 0$ is used in [39]. The emitter minority carrier induced noise current at the emitter-side neutral to depletion boundary of the EB junction, i_b^E , is analogous to the base minority carrier induced noise current at the base-side neutral to depletion boundary of the EB junction, i_e^B ($= i_b^B + i_c^B$). Therefore, the PSD of i_b^E takes the functional form of the PSD of i_e^B in [39], that is,

$$S_{ib}^E = 4kT\Re(Y_{11}^E) - 2qI_b^E, \quad (2.68)$$

where Y_{11}^E is the input admittance seen by the base terminal due to emitter hole injection. At low frequency limit, $Y_{11}^E \approx qI_b^E/kT$, hence $S_{ib}^E \approx 2qI_b^E$.

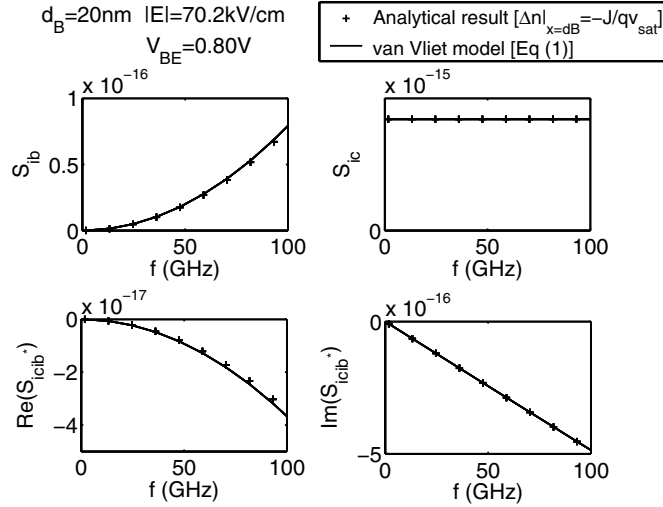


Figure 2.12: Evaluation of van Vliet model for base region noise under $d_B = 20\text{nm}$, $\eta = 5.4$ ($|E|=70.2\text{ kV/cm}$), $V_{BE}=0.8\text{V}$. $A_E=1\text{ cm}^2$.

The emitter hole density fluctuations induce emitter electron density fluctuations to maintain quasi-neutrality due to dielectric relaxation. The electron density fluctuations, however, induce electron current fluctuation only at the emitter contact but not at the depletion to neutral boundary, because electrons are majority carriers in the emitter. Therefore the emitter hole noise only contributes to the base current noise i_b , but not the collector current noise i_c . The PSDs of the total i_b and i_c can then be obtained as

$$\begin{aligned}
 S_{ib}^{EB} &= 4kT\Re(Y_{11}^{EB}) - 2qI_b, & S_{ic}^{EB} &= 4kT\Re(Y_{22}^{EB}) + 2qI_c \approx 2qI_c, \\
 S_{icib^*}^{EB} &= 2kT(Y_{21}^{EB} + Y_{12}^{EB*} - g_m) \approx 2kT(Y_{21}^{EB} - g_m), & & (2.69)
 \end{aligned}$$

where

$$\begin{aligned}
 Y_{11}^{EB} &= Y_{11}^E + Y_{11}^B, & I_b &= I_b^E + I_b^B, \\
 Y_{21}^{EB} &= Y_{21}^B, & Y_{22}^{EB} &= Y_{22}^B, & Y_{12}^{EB} &= Y_{12}^B.
 \end{aligned}$$

Interestingly, (2.69) has the same functional form as (2.67), meaning that the van Vliet model in (2.67) can be directly applied to include emitter hole noise by simply replacing Y^B with Y^{EB} , the Y-parameters of base and emitter regions. So far, the effect of electron transport in the CB SCR on Y-parameters and noise has not been taken into account.

2.3.2 1-D solution

Similarly, the PSD for emitter hole noise S_{ib}^E of the 1-D Langevin equation solution for the emitter can be obtained from the S_{ie}^B of the 1-D Langevin equation solution for the base. That is

$$\begin{aligned}
S_{ib}^E = A_E \left[& |E|^2 \bar{K} \frac{d_E}{-\tilde{\alpha}_1 - \tilde{\alpha}_1^* + \alpha_1} \left(e^{-\tilde{\alpha}_1 - \tilde{\alpha}_1^* + \alpha_1} - 1 \right) \right. \\
& + |F|^2 \bar{K} \frac{d_E}{-\tilde{\alpha}_2 - \tilde{\alpha}_2^* + \alpha_1} \left(e^{-\tilde{\alpha}_2 - \tilde{\alpha}_2^* + \alpha_1} - 1 \right) \\
& + E^* F \bar{K} \frac{d_E}{-\tilde{\alpha}_1^* - \tilde{\alpha}_2 + \alpha_1} \left(e^{-\tilde{\alpha}_1^* - \tilde{\alpha}_2 + \alpha_1} - 1 \right) \\
& + E F^* \bar{K} \frac{d_E}{-\tilde{\alpha}_1 - \tilde{\alpha}_2^* + \alpha_1} \left(e^{-\tilde{\alpha}_1 - \tilde{\alpha}_2^* + \alpha_1} - 1 \right) \\
& + \text{first 4 lines, substitute } \alpha_1 \rightarrow \alpha_2 \text{ and } \bar{K} \rightarrow \bar{L} \\
& \left. + \text{first 4 lines, substitute } \alpha_1 \rightarrow \eta \text{ and } \bar{K} \rightarrow \overline{KL} \right], \tag{2.70}
\end{aligned}$$

where

$$\begin{aligned}
E &= -\frac{\tilde{\alpha}_1}{d_E (1 - \tilde{\kappa} e^{-2\tilde{\theta}})}, \quad F = \frac{\tilde{\kappa} e^{-2\tilde{\theta}} \tilde{\alpha}_2}{d_E (1 - \tilde{\kappa} e^{-2\tilde{\theta}})}, \\
\bar{K} &= \frac{4q^2 D_p p_{00} e^{\frac{V_{BE}}{V_T}}}{1 - \kappa^{-1} e^{2\theta}}, \quad \bar{L} = \frac{4q^2 D_p p_{00} e^{\frac{V_{BE}}{V_T}}}{1 - \kappa e^{-2\theta}}, \quad \overline{KL} = 4q^2 D_p p_{00}. \\
\alpha_1 &= \tilde{\alpha}_1|_{\omega=0}, \quad \alpha_2 = \tilde{\alpha}_2|_{\omega=0}, \quad \kappa = \tilde{\kappa}|_{\omega=0}. \\
\tilde{\kappa} &= \frac{D_p \tilde{\alpha}_1 - v_{sr} d_E}{D_p \tilde{\alpha}_2 - v_{sr} d_E}, \quad \tilde{\alpha}_1 = \frac{\eta_E}{2} + \tilde{\theta}, \quad \tilde{\alpha}_2 = \frac{\eta_E}{2} - \tilde{\theta}, \quad \tilde{\theta} = \sqrt{\left(\frac{\eta_E}{2}\right)^2 + \frac{d_E^2}{D_p \tau_p} + \frac{j\omega d_E^2}{D_p}}. \tag{2.71}
\end{aligned}$$

Here v_{sr} is the emitter surface recombination velocity, d_E is emitter thickness, η_E represents the emitter built-in field due to non-uniform doping, D_p is the emitter hole diffusion coefficient, and τ_p is the emitter hole life time. Consequently, the total base and collector current noise PSDs can be obtained by adding S_{ib}^E to S_{ib} only. In order to evaluate (2.68), Y_{11}^E and I_b^E are derived as

$$Y_{11}^E = e \frac{p_{00}}{V_T} e^{\frac{V_{BE}}{V_T}} \frac{v_{sr}}{\delta} \left(\frac{\eta}{2} + \theta \frac{e^{-\tilde{\alpha}_2} + \tilde{\kappa} e^{-\tilde{\alpha}_1}}{e^{-\tilde{\alpha}_2} - \tilde{\kappa} e^{-\tilde{\alpha}_1}} \right), \quad (2.72)$$

$$I_b^E = e p_{00} \left(e^{\frac{V_{BE}}{V_T}} - 1 \right) \frac{v_{sr}}{\delta} \left(\frac{\eta}{2} + \theta \frac{e^{-\alpha_2} + \kappa e^{-\alpha_1}}{e^{-\alpha_2} - \kappa e^{-\alpha_1}} \right), \quad (2.73)$$

where all parameters are given in (2.71).

2.3.3 Evaluation of finite surface recombination velocity effect

Fig. 2.13 compares two S_{ib}^E values versus frequency, which are the analytical results of (2.70) and the modeling result using (2.70), (2.72) and (2.73). Three values for the surface recombination velocity are used. Clearly the finite surface recombination velocity has only a negligible effect on the accuracy of (2.68). Furthermore, the frequency dependence of S_{ib}^E is weak. Since only

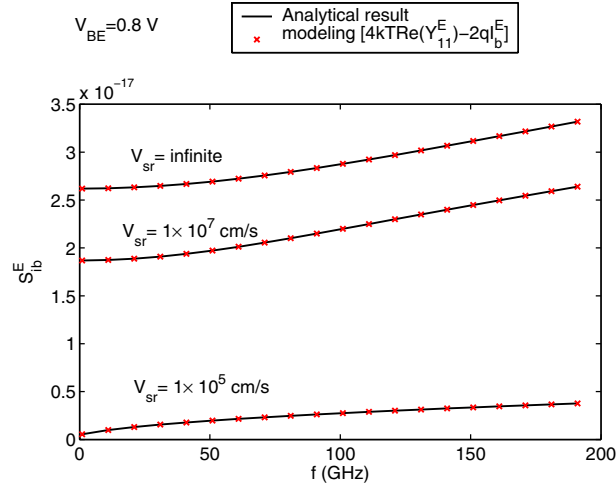


Figure 2.13: Evaluation of emitter hole noise model in (2.68). $\tau_p = 1.54 \times 10^{-7} s$. $\eta_E=0$. $p_{00} = 6.66/cm^3$. $T = 300K$. $d_E=120$ nm. $V_{BE}=0.8$ V. $\mu_p=220$ cm/cs². $A_E=1$ cm².

the diffusion noise is taken into account here, the result above is not exact for the emitter where GR noise is non-negligible. However, when the GR current is significant, the effect of surface recombination velocity is reduced.

2.3.4 Comparison of base electron and emitter hole contributions to S_{ib}

This comparison is based on an HBT constructed for this study with $\beta=235$ and $f_T=200$ GHz. A CB SCR delay is included as detailed in Chapter 5. Fig. 2.14 shows a plot of S_{ib}^E and S_{ib}^B versus frequency at $V_{BE}=0.8$ V. The graph shows that only for $f<15$ GHz is S_{ib}^B negligible. For $f>30$ GHz, S_{ib}^B dominates S_{ib} . S_{ib} has a strong frequency dependence due to base electron noise.

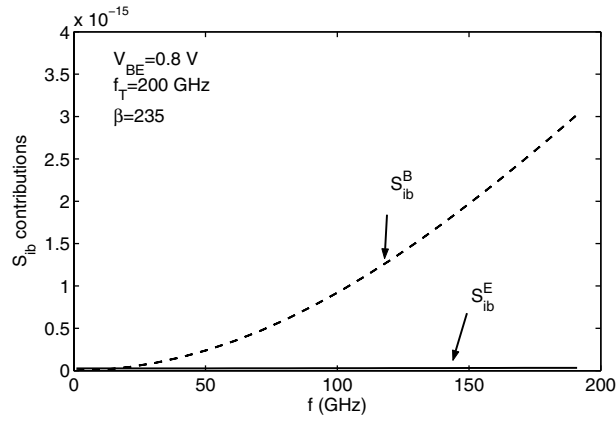


Figure 2.14: Comparison of base electron and emitter hole contributions to S_{ib} . $\tau_p = 1.54 \times 10^{-7}s$. $\eta_E=0$. $p_{00} = 6.66/cm^3$. $T = 300K$. $d_E=120$ nm. $V_{BE}=0.8$ V. $\mu_p=220$ cm/cs². $\tau_n = 1.54 \times 10^{-7}s$. $\eta_B=5.4$. $n_{00} = 333/cm^3$. $d_E=20$ nm. $\mu_n=450$ cm/cs². $V_{exit} = 1 \times 10^7$ cm/s. $\tau_c = 0.57ps$. $A_E=1$ cm². The units of y-axis is A²/Hz. $A_E=1$ cm².

2.4 Compact noise model including distributive effect

2.4.1 Compact noise model assuming uniform f_T across EB junction

The technique commonly used to deal with transistor distributive effects is the segmentation method, where the transistor is divided into many narrow 1-D sub-transistors and these sub-transistors are then connected by divided base resistances. Fig. 2.15 shows the small signal equivalent circuit for this method. Y_{11} and Y_{21} of each sub-transistor naturally include non-quasistatic (NQS) effect. Y_{11} includes the input NQS effect, while Y_{21} includes the output NQS effect. The resistances have $4kTR$ thermal noise. The base and collector current noises of each segment can be described by the van Vliet model if the CB SCR effect is not important.

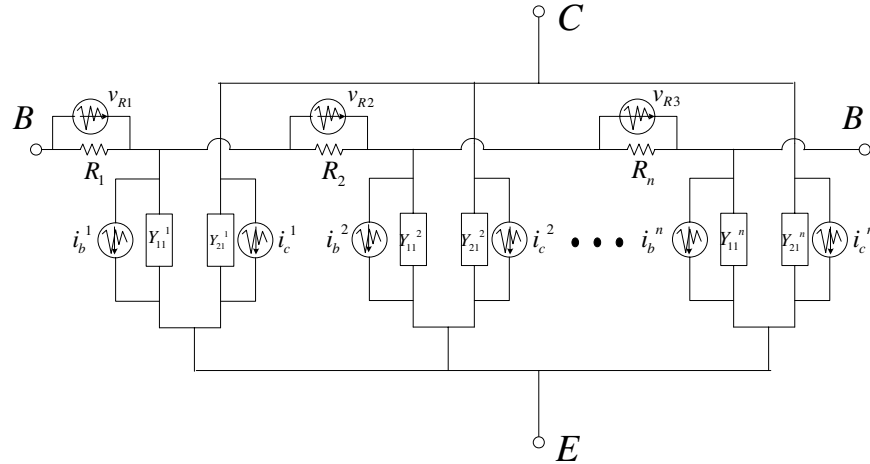


Figure 2.15: Small signal equivalent circuit for a transistor divided into 1-D sub-transistors.

The objective is to develop a compact noise model that includes as few noise sources as possible, with their analytical expressions. Although a general analytical solution is hard to achieve, a compact noise model with only three noise sources can be derived by assuming the same f_T for all of the 1-D sub-transistors according to the crowding theory in [41]. Fig. 2.16 shows the lumped small signal equivalent circuit, together with the lumped noise sources.

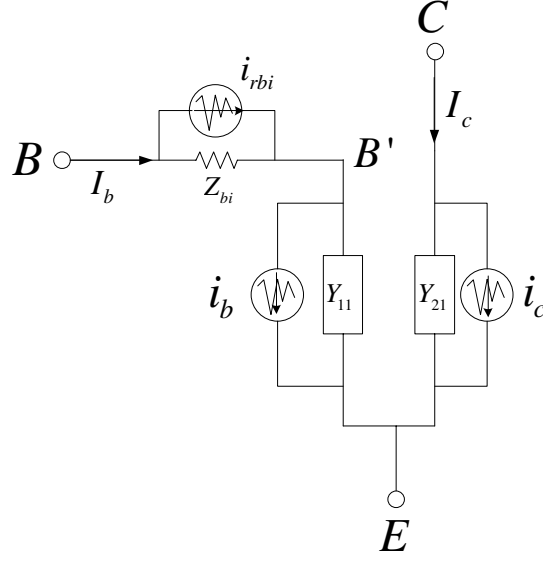


Figure 2.16: Compact noise model assuming uniform f_T for whole EB junction [41].

Since the output conductance g_o is negligible for SiGe HBTs, the lumped Y_{11} and Y_{21} can be chosen to be the sum of Y_{11} and Y_{21} for all the sub-transistors, explicitly,

$$Y_{11} = Y_{11}^1 + Y_{11}^2 + \dots + Y_{11}^n,$$

$$Y_{21} = Y_{21}^1 + Y_{21}^2 + \dots + Y_{21}^n.$$

The lumped base impedance Z_{bi} has a complex expression, which relates to the distributive base resistances and EB capacitances. Denote the low frequency limit of the real part of Z_{bi} as r_{bi} , the lumped AC small signal value of the intrinsic base resistance. For transistors with double base contacts and at low current levels,

$$r_{bi} = R_{BV} \equiv \frac{1}{12} R_{\square} \frac{W_E}{L_E}, \quad (2.74)$$

where L_E and W_E are the base length and base width, respectively, and R_{\square} is the base sheet resistance.

The lumped base and collector current noises i_b and i_c are the sum of the noise currents of the 1-D sub-transistors with no crowding effect

$$i_b = i_b^1 + i_b^2 + \dots + i_b^n,$$

$$i_c = i_c^1 + i_c^2 + \dots + i_c^n.$$

i_b and i_c are correlated.

The noise current assigned to Z_{bi} , i_{rbi} , lumps together all the distributive noise effects, and therefore contains not only the distributive base resistance thermal noise, but also the distributive intrinsic base current noise. It is an important result of [41] that i_{rbi} is not correlated with either i_b and i_c once a uniform f_T across EB junction is assumed. Thus, the PSD of i_{rbi} , $S_{i_{rbi}}$, is generally frequency dependent through the frequency dependence of the intrinsic base current noise and has a complex expression [41]. Denote the DC voltage drop across Z_{bi} as $V_{B_x B_i}$. For a circular emitter BJT, the low frequency limit of $S_{i_{rbi}}$ is given as

$$S_{i_{rbi},cir} = \frac{4kT}{R_{BV}} \Delta f \frac{5e^{V_{B_x B_i}/V_T} + 1}{6}. \quad (2.75)$$

For a rectangular emitter BJT, the low frequency limit of $S_{i_{rbi}}$ is given as

$$S_{i_{rbi},rec} = \frac{4kT}{R_{BV}} \Delta f \frac{5e^{V_{B_x B_i}/V_T} + 4}{9}. \quad (2.76)$$

These expressions are hard to use for noise modeling based on small signal equivalent circuits, because the parameters used are not available in a small signal equivalent circuit. At low frequencies, $S_{i_{rbi}}$ can be related to r_{bi} by

$$S_{i_{rbi}} = 4kT/r_{bi} - 2qI_B/3. \quad (2.77)$$

The derivation is given in Appendix B based on [41]. (2.77) is exact for circular emitter BJTs, and has less than a 3% error for rectangular BJTs. At low current levels or under weak crowding strength, (2.77) simplifies to become $4kT/r_{bi}$, the traditional thermal noise model for r_{bi} . Note that (2.77) is accurate only when the input NQS effect is included in the intrinsic transistor model, as assumed by [41]. However, in current CAD tools, QS equivalent circuits are used, which cause some problems for r_{bi} noise modeling. Even when the NQS equivalent circuit is used, the r_{bi} needed for R_n fitting is not always equal to r_{bi} . These issues are discussed in more detail in Chapter 5.

2.4.2 NQS and QS base resistance

Based on the crowding theory [41], Fig. 2.17 (a) with NQS input is the correct equivalent circuit for intrinsic transistor where r_{bi} is the true lumped intrinsic base resistance. r_{bi} is generally dependent on I_b . If the carrier density modulation in base is not considered, according to Appendix B

$$r_{bi} \approx \frac{R_{BV}}{1 + I_b R_{BV}/V_T}. \quad (2.78)$$

(2.78) implies that r_{bi} can be modeled by R_{BV} paralleled with g_{be} . Clearly the I_b dependence is more severe at low temperatures. An exact consideration of carrier density modulation is difficult, but if an averaged V_{BE} is used to measure the level of carrier density modulation, the r_{bi} can be derived as

$$\begin{aligned} \frac{1}{r_{bi}} &\approx \frac{1}{R_{BV}} \left(\frac{3 + \sqrt{1 + I_b \frac{4n_i^2}{N_A^2 I_{bs}}}}{4} \right) + \frac{I_b}{V_T} \\ &= \frac{1}{R_{BV}} \left(\frac{3 + \sqrt{1 + \frac{I_b}{I_{bk}}}}{4} \right) + \frac{I_b}{V_T}, \end{aligned} \quad (2.79)$$

where N_A is the base doping concentration, I_{bs} is the base saturation current, and

$$I_{bk} \equiv \frac{4n_i^2}{N_A^2 I_{bs}} \approx A_E \frac{4eD_n N_A}{\beta d_B}. \quad (2.80)$$

A_E is the emitter area. Two parameters, R_{BV} and I_{bk} , are needed to model the bias dependence of r_{bi} . For high speed SiGe HBTs at room temperature, R_{BV} is quite small, and the carrier density modulation is negligible, leading to the weak I_b dependence of r_{bi} as shown in the experimental extraction in Chapter 3 and in Fig. 2.18 below by analytical calculation.

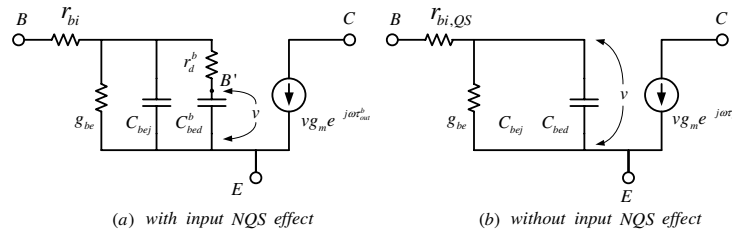


Figure 2.17: Equivalent circuit for intrinsic base of bipolar transistor with r_{bi} : (a) With NQS input; (b) With QS input.

If the QS and NQS equivalent circuits in Fig. 2.17 are used to model the same Y-parameters, $r_{bi,QS}$ becomes a lumped resistance related to the true intrinsic resistance r_{bi} and the NQS delay resistance r_d^b ($r_d^b = \tau_{in}^b / C_{bed}^b$). Applying the Taylor expansion method described in Chapter 3 yields

$$r_{bi,QS} \approx r_{bi} + r_d^b \left(\frac{C_{bed}^b}{C_{bed}^b + C_{bej}} \right)^2. \quad (2.81)$$

At low biases $r_d^b C_{bed}^b = \tau_{in}^b$ is a constant. Since C_{bed}^b increases versus bias and C_{bej} is nearly constant, the ratio $C_{bed}^b / (C_{bed}^b + C_{bej})^2$ has a maximum value at $C_{bed}^b = C_{bej}$. This means that $r_{bi,QS}$ should increase at low biases and fall at high biases. $r_{bi,QS}$ is clearly larger than r_{bi} . Fig. 2.18 compares r_{bi} , $r_{bi,QS}$ and r_d^b extracted from the 1-D Y-parameters in (2.47). f_T is shown for reference. r_{bi} is calculated using (2.79). Peak $f_T=186$ GHz. Note f_T roll off is not included.

$\beta=235$. $\tau_c = 0.57ps$. $C_{bej}=38$ fF. $W_E=0.12 \mu m$. $L_E=18 \mu m$. These parameters are consistent with those for experimental 200 GHz SiGe HBTs. $V_{BE}=1.02$ V when $\Delta n = N_A$ for base injection. For 200 GHz SiGe HBTs, f_T rolls off around this V_{BE} . So the $V_{BE}<1.02$ V range is concerned for AC performance, where r_{bi} is closely bias independent. $r_{bi,QS}$ indeed shows a bell shape and deviates from r_{bi} by 43% at the bias when $C_{bed}^b = C_{bej}$.

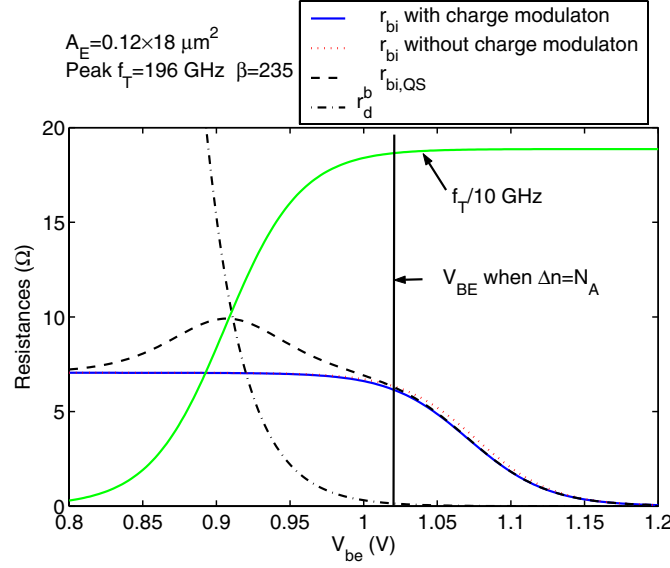


Figure 2.18: Comparison between r_{bi} , $r_{bi,QS}$ and r_d^b . $\tau_p = 1.54 \times 10^{-7}s$. $\eta_E=0$. $p_{00} = 0.466 /cm^3$. $T = 300K$. $d_E=120$ nm. $\mu_{p0}=225$ cm²/V. $\tau_n = 1.54 \times 10^{-7}s$. $\eta_B=5.4$. $n_{00} = 23.3 /cm^3$ ($N_A = 4.3 \times 10^{18} /cm^3$). $d_E=20$ nm. $\mu_{n0}=450$ cm²/V. $V_{exit} = 1 \times 10^7$ cm/s. $\tau_c = 0.57ps$. $C_{bej}=38$ fF. $W_E=0.12 \mu m$. $L_E=18 \mu m$. $A_E=1$ cm².

At high current levels, $r_{bi,QS} \approx r_{bi} + r_d^b$. Thus, it is meaningful and interesting to compare r_{bi} with r_d^b under different parameter changes.

- W_E, d_B (2.48) shows that $r_d^b \propto d_B/W_E$. On the contrary, $r_{bi} \propto W_E/d_B$. During device scaling, both W_E and d_B are scaled. Therefore, for different generation devices, it is difficult to compare the relative importance of r_d^b . For the same generation devices, however, the smaller the emitter width, the more important r_d^b .
- L_E, N_A (2.48) shows that $r_d^b \propto 1/L_E N_A$, the same as r_{bi} .

- *Ge gradient* (η) As shown in Fig. 2.6, η reduces r_d^b . However η has little effect on r_{bi} . Therefore, for two devices that only differ in terms of Ge gradient, the one with the larger Ge gradient will have less modeling error using QS equivalent circuit at high current levels.

Overall, unlike f_T , *one cannot compare the relative importance of r_d^b for different generations of devices without knowing the design details of each generation.*

2.5 Present noise models and implementation problems

2.5.1 SPICE model

The default i_b and i_c noise models in current CAD tools are the same as those used in SPICE [42]. i_b and i_c are assumed to be shot like and uncorrelated. This is denoted as SPICE model and the PSDs are given by

$$S_{ib}^{SPICE} = 2qI_B, \quad S_{ic}^{SPICE} = 2qI_C, \quad S_{icib^*}^{SPICE} = 0. \quad (2.82)$$

Both the theoretical analysis above and experimental data have shown that this highly simplified model is not sufficient for high frequency applications, particularly at the higher biasing currents required to achieve high speed operation [43–48]. In particular, S_{ib} has been shown to increase with frequency, and the correlation S_{icib^*} is significant and cannot be neglected [43, 45–47, 49].

2.5.2 Transport noise model

The transport noise model [43] [44] has recently been shown to work better than the SPICE model [43, 45] by taking into account the correlation. The essence of this model is that the collector current noise is transported from the electron current shot noise in the emitter-base junction, with

a noise transit time τ_n [43]:

$$\begin{aligned}
S_{ib}^{Tran} &= 2qI_B + 4qI_C[1 - \Re(e^{j\omega\tau_n})], \\
S_{ic}^{Tran} &= 2qI_C, \\
S_{icib*}^{Tran} &= 2qI_C(e^{-j\omega\tau_n} - 1).
\end{aligned} \tag{2.83}$$

However, in practical devices, with only a single parameter τ_n , simultaneous fitting of measured S_{ib} and S_{icib*} can become difficult. Simultaneous fitting of NF_{min} , R_n , G_{opt} and B_{opt} is challenging in some cases.

2.5.3 Brutal use of van Vliet model

The van Vliet model serves as the basis of several other models, e.g. [47, 50–53]. Since the van Vliet derivation does not consider electron transport in the collector-base space charge region (CB SCR), characterized by transit time τ_c , (2.67) cannot be automatically extended to include the CB SCR effect simply by replacing Y_B with Y-parameters of whole intrinsic transistor [5]. In the literature [50–53], the van Vliet model is often used unphysically:

- Y_B should explicitly include the input NQS effect, that is, $\Re(Y_{11}^B)$ should be frequency dependent, so that the frequency dependence of S_{bi}^B can be modeled. However, all the implementations reported use QS equivalent circuits whose $\Re(Y_{11}^B)$ is frequency independent.
- The Y-parameters of the whole intrinsic transistor, including the CB SCR, are used in (2.67), the results are recognized as the noise of whole transistor without justification. For scaled bipolar transistors, CB SCR electron transport becomes more significant than base electron transport. The van Vliet model must be improved to including this effect.

2.5.4 $4kTr_{bi}$ for r_{bi} noise

With the uniform f_T assumption, the noise PSD of $i_{r_{bi}}$ can be approximated with $4kT/r_{bi}$ for SiGe HBTs whose crowding effect is negligible. This is the base resistance noise model commonly used in CAD tools and in the literature [42, 50–53]. However, problems were encountered when using $4kTr_{bi}$ for noise modeling based on either QS or NQS lumped equivalent circuits: First, the noise resistance R_n cannot be well modeled, as it is sensitive to base hole noise. One has to use an empirical S_{ic} based on noise extraction, which is unphysically larger than $2qI_c$ for 50 GHz SiGe HBTs (see Chapter 4). Another problem is that the absolute value of the imaginary part of the noise parameter Y_{opt} , i.e. B_{opt} , is overestimated by the van Vliet model based on NQS equivalent circuit. The deviation cannot be eliminated by choosing an appropriate r_{bi} .

The uniform f_T assumption is not justified for high speed SiGe HBTs with narrow emitter width ($\leq 0.24\mu m$). The f_T within the fringe transistor is smaller than that in the main transistor due to larger base width. Such non-uniform f_T does not have a significant effect on i_b and i_c noises. However, the base hole noise now has to be modeled by a noise source at the input together with a *correlated* noise current source at the output [6].

2.6 Methodologies to improve noise modeling

Two methods are proposed to improve noise modeling in this work:

- The first method is to implement a semi-empirical model for the intrinsic transistor noise based on noise extraction for the QS equivalent circuit, as detailed in Chapter 4. Eq. (2.77) is used for $S_{i_{r_{bi}}}$ and then the intrinsic noise S_{ib} , S_{icib^*} and S_{ic} are extracted from device noise parameters using standard noise de-embedding methods [54]. Equations can then be developed to model these noise sources. The deviation caused by the use of a QS input equivalent circuit, and hence the lumping of input NQS resistance into r_{bi} , as well as the use of (2.77), is all included in the intrinsic noise. The extracted S_{ib} and S_{ic} are thus not

precisely the physical intrinsic transistor noises, which can only be obtained through higher order modeling that includes input NQS and noise crowding effects. The noise sources and their correlation, are first modeled as functions of frequency (ω). The coefficients are then extracted and modeled as a function of biasing current through g_m . As the QS equivalent circuit is used, existing parameter extraction methods can be applied, and the proposed model can be readily implemented in current compact models. This method was verified in VBIC model using Verilog-A by Advance Design System (ADS) circuit simulator.

- The second method improves compact RF noise modeling for SiGe HBTs based on NQS equivalent circuit using new electron and hole noise models as detailed in Chapter 5. The impact of CB SCR on electron RF noise is examined to be important for scaled SiGe HBTs. The van Vliet model is then improved to account for the CB SCR effect. The impact of the fringe BE junction on base hole noise is further investigated. Due to the fringe effect, the base hole noise should be modeled with correlated noise voltage source and noise current source in hybrid representation. The base noise resistance is found to be different from r_{bi} , and cannot be explained by fringe effect alone. An extra parameter R_{bn} is included for base noise resistance. With a total of four bias-independent model parameters, the combination of electron and hole noise model provides excellent noise parameter fittings for frequencies up to 26 GHz and all biases before f_T roll off for three generations of SiGe HBTs.

2.7 Summary

Diffusion noise is the major noise source in SiGe HBTs. The van Vliet model is still applicable for typical SiGe HBTs with a base built-in field, and can be directly extended to include emitter hole noise. The CB SCR effect is important for aggressively scaled devices, and should be included in noise modeling. The fringe BE junction effect impacts base hole noise, and should be included for noise modeling. Present noise models are not sufficiently accurate for RF noise modeling at

high frequencies. Both semi-empirical and physical methods are used in this work to improve RF noise modeling.

CHAPTER 3

SMALL SIGNAL PARAMETER EXTRACTION

Small-signal equivalent circuit accurately modeling both AC and noise characteristics of SiGe HBTs is very useful for RF circuit design as well as understanding of device physics. The topology of equivalent circuit determines the physics effects that can be accounted for, accuracy of final AC and noise characteristics, and affects circuit parameter extraction procedure as well as the physical soundness of extracted equivalent circuit parameters. Microscopic noise physics based noise models of bipolar transistors described in Chapter 2 require modeling of input NQS effect. This chapter examines small signal equivalent circuit modeling of input NQS effect including CB CSR delay, and its parameter extraction.

Accurate parameter extraction is challenging in practice due to the large number of parameters involved, in spite of the various methods proposed, including both direct or analytical methods and numerical optimization based methods. Including the input NQS effect makes the circuit topology even more complex. Numerical methods often lead to physically meaningless values, as reviewed in [55]. The full analytical expressions of Y/Z-parameters are too complex to be directly used for extraction. This chapter presents a new direct extraction method based on Taylor series expansion analysis of Y/Z-parameter expressions [8]. The real part of Y/Z-parameters is approximated up to second order of frequency. The imaginary part is approximated up to first order. The expansion coefficients are obtained as simple functions of equivalent circuit parameters, allowing straightforward parameter extraction. The extracted parameters, such as intrinsic base resistance and excess phase delay time, show more physical bias dependences compared to conventional extraction. The

utility of this method is demonstrated using SiGe HBTs of different sizes from different technology generations, a SiGe HBT with 180 GHz peak f_T is used below for illustration of extraction procedure.

3.1 Necessity of including input NQS effect in equivalent circuit

Of particular interest to modeling of the RF noise in the base current is the frequency dependence of the real part of the input admittance, $\Re(Y_{11})$, due to base electron transport, which is responsible for the frequency dependence of base current noise as well as the correlation between base and collector current RF noises as discussed in Chap 2. We have also show the NQS equivalent circuit for base region in Fig. 2.3. The base minority carrier charge responds to base emitter voltage by the input NQS delay time τ_{in}^b , then the collector current at the end of base region responds to the stored base minority carrier charge by the output NQS delay time τ_{out}^b . For a real device, particularly modern SiGe HBTs, the output collector current is further delayed, compared to the current at the end of the base, by the CB SCR transit time τ_c . Although the circuit topology of Fig. 2.3 (a) was derived for the base region, the same circuit topology is capable of including τ_{in}^b , τ_{out}^b and τ_c delays, as shown below, with proper modifications to values of its elements.

However, in present BJT models e.g. SPICE Gummel-Poon and VBIC, and all the recent direct parameter extraction methods [55–61], a circuit topology of Fig. 2.3 (b) is used for the intrinsic transistor. Although τ_{out}^b has been included in Fig. 2.3 (b), the input NQS effect is neglected. We found problems in using such circuit topology for both AC and noise modeling of high peak f_T SiGe HBTs. First of all, with Fig. 2.3 (b), the real part of Y_{11} of intrinsic device, $\Re(Y_{11})$, is frequency independent [3, 4]. Correct modeling of $\Re(Y_{11})$ is crucial for a physically meaningful implementation of microscopic noise physics based base and collector current RF noise models [2],

such as the van Vliet model, see (2.67). The increase of base current noise with frequency is directly proportional to the $\Re(Y_{11})$ of the base and this part of the base current noise is correlated with the collector current noise.

Another major problem with using the circuit topology with QS input is extraction of intrinsic base resistance, which we denote as $r_{bi,QS}$. $r_{bi,QS}$ is often extracted using impedance semicircle fitting method [62], which determines base resistance from the x-axis intercept of a semicircle fitted to $(\Re[H_{11}], \Im[H_{11}])$ points of different frequencies on a complex impedance plane for an equivalent circuit excluding the extrinsic base resistance and CB capacitance. We find that the $r_{bi,QS}$ extracted increases unphysically at low base currents because r_d^b is lumped into r_{bi} [4]. Such unphysical result in r_{bi} extraction was also observed by others, e.g. in [63], and is typical of existing r_{bi} or r_b extraction. The use of $r_{bi,QS}$ also leads to an overestimation of minimum noise figure [4]. The extracted excess phase delay time of the intrinsic device shows a strong bias-dependence even at low current levels, a clearly unphysical result. The inaccurate excess phase delay time directly affects the correlation between base current noise and collector current noise through $\Im(Y_{21})$ in van Vliet model, see (2.67). Using an equivalent circuit based on Fig. 2.3 (a) which explicitly includes the input NQS effect, the abnormal bias dependence of $r_{bi,QS}$ can be explained and avoided. A more physical value of r_{bi} is obtained, which also helps improving noise modeling. The extracted excess phase delay time shows a more physical bias-dependence [8].

3.2 NQS Equivalent circuit

The input NQS equivalent circuit of Fig. 2.3 (a) proposed by Winkel was based on frequency domain solution in the base only. For modern SiGe HBTs, it is necessary to include the impact of CB SCR.

3.2.1 CB SCR effect

The Y-parameters of base, Y^{bs} , can be obtained from Fig. 2.3 (a) as

$$Y_{11}^{bs} = g_{be} + j\omega C_{bej} + \frac{j\omega C_{bed}^b}{1 + j\omega\tau_{in}^b}, \quad Y_{21}^{bs} = g_m \frac{e^{-j\omega\tau_{out}^b}}{1 + j\omega\tau_{in}^b}. \quad (3.1)$$

Y_{12}^{bs} and Y_{22}^{bs} are equal to zero. With CB SCR, the Y-parameters of whole transistor, Y^{al} , can be calculated from Y^{bs} and τ_c as [5]

$$Y_{11}^{al} = Y_{11}^{bs} + (1 - \lambda)Y_{21}^{bs}, \quad Y_{21}^{al} = \lambda Y_{21}^{bs}, \quad (3.2)$$

where $\lambda = (1 - e^{-2j\omega\tau_c})/(2j\omega\tau_c)$. (More details in (5.1)). A close inspection shows that we can still use the circuit topology of Fig. 2.3 (a) or Fig. 3.1 (a) to describe Y^{al} with an accuracy up to the second order in frequency. The intrinsic NQS equivalent circuit including CB SCR is shown in Fig. 3.1 (b). The equivalent circuit parameters of whole transistor (C_{bed} , r_d or τ_{in} , and τ_{out}) are related to those of base region (C_{bed}^b , r_d^b or τ_{in}^b , and τ_{out}^b) and τ_c . Denoting $\tau_{tr} \equiv C_{bed}/g_m$ and $\tau_{tr}^b \equiv C_{bed}^b/g_m$, we find

$$\begin{aligned} \tau_{tr} &= \tau_{tr}^b + \tau_c, \\ \tau_{in} &= \tau_{in}^b + \tau_c \frac{\tau_{out}^b + 2\tau_c/3}{\tau_{tr}^b + \tau_c}, \\ \tau_{out} &= \tau_{out}^b + \tau_c \frac{\tau_{tr}^b - \tau_{out}^b + \tau_c/3}{\tau_{tr}^b + \tau_c}. \end{aligned} \quad (3.3)$$

Detailed derivation is given in Appendix C. (3.3) reveals that $\tau_{in} \rightarrow 2/3\tau_{tr}$ and $\tau_{out} \rightarrow 1/3\tau_{tr}$ when $\tau_c \gg \tau_{tr}^b, \tau_{in}^b, \tau_{out}^b$, the case of SiGe HBTs with ultra narrow base.

To further investigate the τ_c effect, we use analytical Y-parameter expressions of ideal 1-D base region derived from frequency domain solution of the drift-diffusion equations in (2.47). First, we extract τ_{tr}^b, τ_{in}^b and τ_{out}^b from the analytical Y-parameters. Then τ_{tr}, τ_{in} and τ_{out} are evaluated

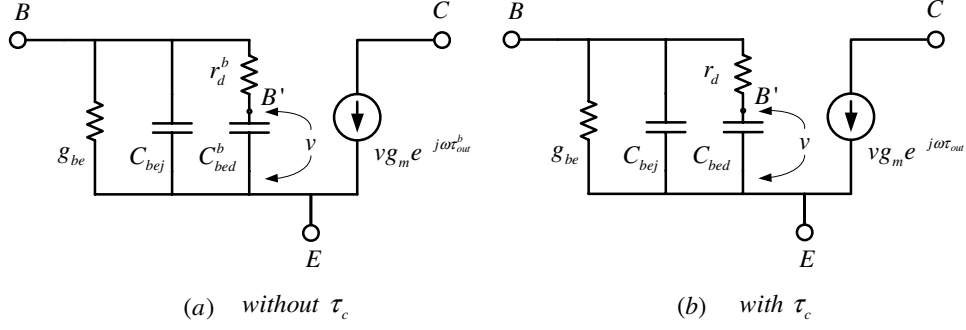


Figure 3.1: Intrinsic NQS small signal equivalent circuit of SiGe HBTs: (a) without τ_c ; (b) with τ_c .

using (3.3). Fig. 3.2 (a) shows τ_{in}/τ_{tr} and τ_{out}/τ_{tr} versus base width for different τ_c at $\eta = 6$, the typical value for SiGe HBTs. τ_c increases the input NQS effect and decreases excess phase delay time for narrow base transistor. Fig. 3.2 (b) shows τ_{in}/τ_{tr} and τ_{out}/τ_{tr} versus base width for different η at $\tau_c=0.6$ ps. For SiGe HBTs with higher Ge grading, i.e. larger η , the normalized input NQS effect becomes larger.

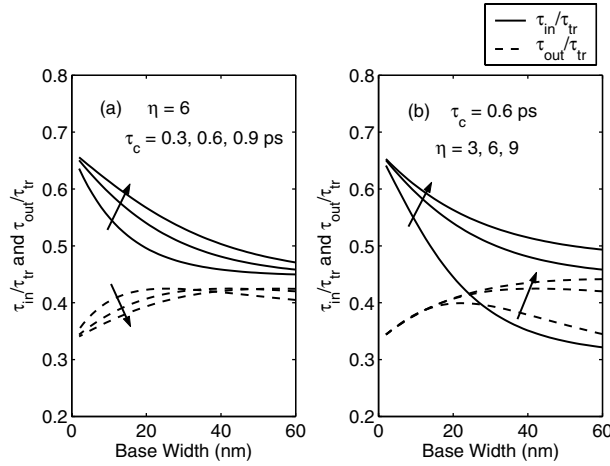


Figure 3.2: CB SCR effect on τ_{in} and τ_{out} . For the 1-D base region, $V_{sat}^{bs} = 1 \times 10^7$ cm/s, $\mu_{n0} = 270$ cm/Vs², $\tau_n=0.154$ μ s, $T=300$ K.

The importance of input NQS can be measured by comparing the frequency dependent part of $\Re(Y_{11})$ with g_{be} ($\approx I_b/V_T$). The frequency dependent part of $\Re(Y_{11})$ can be calculated from (3.2)

as $\omega^2 C_{bed} \tau_{in}$. For fixed frequency, bias, and emitter design, the importance of input NQS can thus be measured by $C_{bed} \tau_{in}$. Fig. 3.3 shows $C_{bed} \tau_{in}$ versus η for different τ_c . The larger τ_c or the larger base Ge gradient, the more important the input NQS effect.

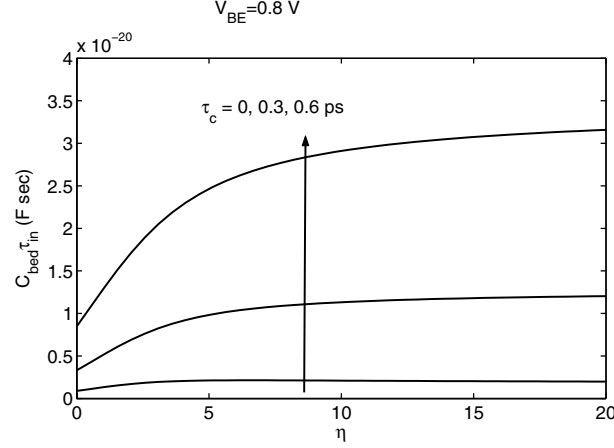


Figure 3.3: CB SCR and Ge gradient impacts on the importance of input NQS effect. For the 1-D base region, $d_B=20$ nm, $V_{sat}^{bs} = 1 \times 10^7$ cm/s, $\mu_{n0} = 270$ cm/Vs², $\tau_n=0.154$ μ s, $T=300$ K. $V_{BE} =0.8$ V.

3.2.2 NQS equivalent circuit

Fig. 3.4 shows the small signal equivalent circuit used. The substrate is tied to emitter to facilitate two-port RF measurements using two GSG probes. Block B_X is the equivalent circuit excluding r_e and substrate network from the full circuit. B_M is the block obtained by excluding r_c from B_X . Block B_{IR} is the intrinsic device with r_{bi} . Block B_I is the intrinsic device without r_{bi} . Note that the control voltage for the transconductance term is the total intrinsic BE voltage drop across r_d and C_{bed} , instead of the voltage across C_{bed} as done in Fig. 2.3 (a). This makes the total excess phase delay time $\tau_{in} + \tau_{out}$, designated as τ_d below. Lumping τ_{in} and τ_{out} into τ_d does not lose modeling accuracy and is advantageous for extraction, as the input NQS and output excess phase delays are now separated. C_{bex} is the extrinsic BE capacitance, for example, the capacitance between base and emitter through spacer, and is non-negligible for small devices of

high f_T SiGe HBTs. The output conductance r_o is neglected due to the large Early voltage in SiGe HBTs. Parameter r_u relating to the V_{CB} modulation of neutral base recombination current has no significant effect on either Y-parameters or RF noise at frequencies above 1 GHz, and is neglected. All other extrinsic parameters have their conventional meanings. For convenience, we define total BE capacitance, total BC capacitance and its partition factor γ as

$$C_{bet} \equiv C_{bed} + C_{bej}, C_{bct} \equiv C_{bcx} + C_{bci}, \gamma \equiv C_{bci}/C_{bct}.$$

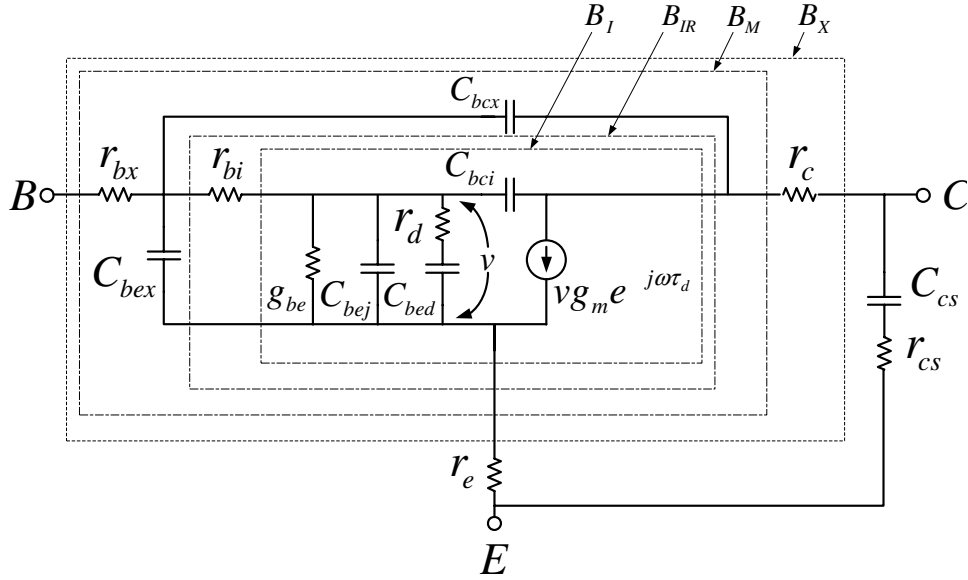


Figure 3.4: Small signal equivalent circuit of SiGe HBTs with substrate tied to emitter.

Now we discuss a few assumptions we will make on the bias dependence of small signal parameters. Extrinsic element r_{bx} , r_c , C_{bex} are considered as bias-independent. γ is also considered as bias-independent. Strictly speaking, BE depletion capacitance C_{bej} is a function of V_{BE} . However, for the RF bias range across which f_T is high, the variation of V_{BE} (0.80–0.92 V) is small, and C_{bej} can be considered bias-independent. The base charge modulation and DC crowding effect are

negligible for SiGe HBTs because of the high base doping [1]. Consequently r_{bi} is weakly bias dependent before high injection base push out occurs. In our extraction method, we first consider r_{bi} as bias-independent during extrinsic parameter extraction. Bias-independent r_{bi} is extracted. Such assumption is justified for high f_T SiGe HBTs due to the high base doping as discussed in Chapter 2. It is important to note that the bias dependent $r_{bi,QS}$ extracted using equivalent circuit without including input NQS effect is a lumped parameter involving r_d and r_{bi} [4]. The bias dependence of $r_{bi,QS}$ can be well reproduced by our NQS circuit with bias-independent r_{bi} as discussed in Section IV. To make our method more general, we also give a method that can extract bias-dependent r_{bi} , where the delay time ratios τ_{in}/τ_{tr} and τ_d/τ_{tr} are considered as constant for all biases.

3.3 Parameter extraction

S-parameters are measured for SiGe HBTs of different process generations with different emitter geometries. Only a 180 peak f_T device is used below for illustration of parameter extraction. The HBT has an emitter area $A_E = 0.12 \times 6 \times 1 \mu\text{m}^2$. S-parameters are measured on-chip using a 8510C Vector Network Analyzer (VNA) from 1-48 GHz. The S-parameters are de-embedded using standard OPEN/SHORT structures. “Active” measurement is made by sweeping V_{BE} (0.80–0.98 V) with $V_{CE}=1.5$ V. The f_T rolls off at $V_{BE}=0.921$ V. “Cold” measurement ($V_{BE}=0$ V, $V_{CE}=1.5$ V) is also made to extract the substrate network and the C_{bc} partition factor γ .

The analytical Y/Z-parameter expressions for each block in Fig. 3.4 can be derived in a way very similar to the derivation in [3]. Note that C_{bej} is not explicitly split from C_{bed} in [3]. The results are shown in Appendix D. We also use the symbolic analysis of MATLAB to obtain these results. The source code is given in Appendix D. Some of the Y-parameters and the inverse of Z-parameters, or their linear combinations, can be used for parameter extraction. We denote them as T . Due to the complexity of equivalent circuit, the exact T expressions, however, are difficult to use for direct parameter extraction. We notice that all of the T expressions are functions of

frequency or ω , and have no singularities at $\omega=0$. Hence we can make Taylor expansions for them at $\omega=0$. The real part of T is expanded up to the second order of ω and the imaginary part up to the first order of ω ,

$$\begin{aligned}\Re(T) &= [\Re(T)_0] + [\Re(T)_2]\omega^2 + o(\omega^2), \\ \Im(T) &= [\Im(T)_1]\omega + o(\omega).\end{aligned}\tag{3.4}$$

We emphasize that the real part expansion consists of only even orders of ω terms and the imaginary part consists of only odd orders of ω terms. Any admittance, impedance or transconductance element containing ω in Fig. 3.4 contains $j\omega$. Since the real part of T only contains even order terms of j , the real part must only contain even order terms of ω . Similarly, the imaginary part of T only contains odd order terms of j , hence the imaginary part must only contain odd order terms of ω . The coefficients directly relate to small signal equivalent circuit parameters and can then be used for parameter extraction, as detailed below. It is critical to accurately extract these coefficients for certain Y/Z-parameter. To extract $\Re(T)_0$ and $\Re(T)_2$, we plot $\Re(T)$ versus ω^2 . A linear relation should be observed at low frequencies. With a linear fitting, the y-axis intercept gives $\Re(T)_0$, and the slope gives $\Re(T)_2$. Fig. 3.5 (a) illustrates the extraction of $\Re(Y_{11}^{BM} + Y_{12}^{BM})_2$ at low, medium and high biases. To extract $\Im(T)_1$, we plot $\Im(T)/\omega$ versus ω^2 . A linear relation is observed at low frequencies. With a linear fitting, the y-axis intercept gives $\Im(T)_1$. Fig. 3.5 (b) illustrates the extraction of $\Im(Y_{22}^{BM})_1$ at low, medium and high biases. One could also extract $\Im(T)_1$ from the slope of $\Im(T)$ versus ω at lower frequencies where the third order term is weak. This, however, is not necessary when plotting $\Im(T)/\omega$ versus ω^2 . We now detail the extraction procedure parameter by parameter.

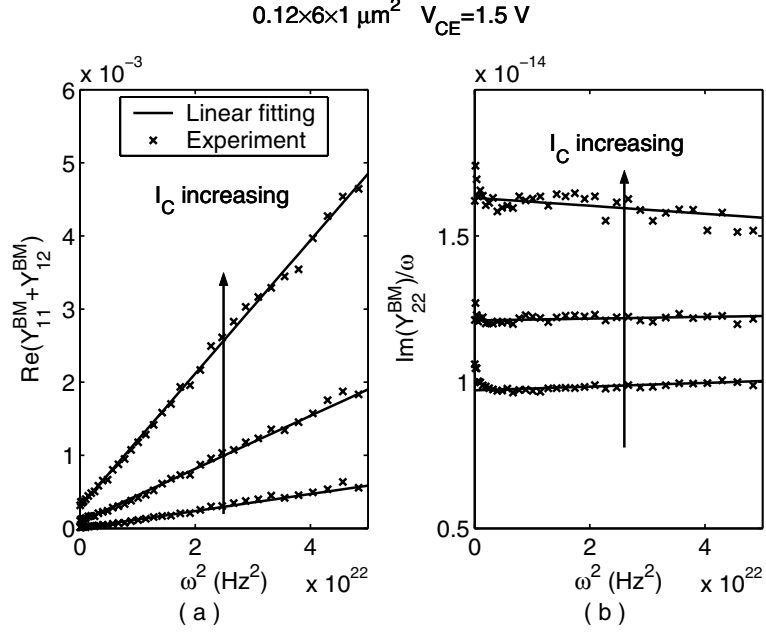


Figure 3.5: Illustration of Taylor expansions coefficient extraction for (a) $\Re(Y_{11}^{BM} + Y_{12}^{BM})_2$, and (b) $\Im(Y_{22}^{BM})_1$.

3.3.1 C_{cs} , r_{cs} , γ and r_e extraction

Cold measurement data is used to extract substrate network (r_{cs} , C_{cs}) using the method in [64], that is

$$C_{cs} = \frac{\Im(Y_{22}^{Cold} + Y_{12}^{Cold})}{\omega}, \quad r_{cs} = \frac{\Re(Y_{22}^{Cold} + Y_{12}^{Cold})}{[\Im(Y_{22}^{Cold} + Y_{12}^{Cold})]^2}. \quad (3.5)$$

The CB capacitance partition factor γ can also be extracted from cold measurement data using the method in [65], explicitly

$$\gamma \approx \frac{\Im(Y_{11}^{Cold} + Y_{12}^{Cold})}{\Im(Y_{12}^{Cold})} \frac{\Re(Y_{12}^{Cold})}{\Re(Y_{11}^{Cold} + Y_{12}^{Cold})}. \quad (3.6)$$

γ usually is small for SiGe HBTs. For example, $\gamma=0.21$ for the device used for illustration. r_e is determined by the y-axis intercept of $\Re(Z_{12})$ versus $1/I_c$. After de-embedding the substrate network and r_e , the Z-parameters of block B_X are known, explicitly,

$$\begin{aligned} Z_{11}^{BX} &= \frac{Y_{22} - \frac{j\omega C_{cs}}{1+j\omega C_{cs}r_{cs}}}{Y_{11}Y_{22} - Y_{12}Y_{21} - Y_{11}\frac{j\omega C_{cs}}{1+j\omega C_{cs}r_{cs}}} - r_e, & Z_{12}^{BX} &= -\frac{Y_{12}}{Y_{11}Y_{22} - Y_{12}Y_{21} - Y_{11}\frac{j\omega C_{cs}}{1+j\omega C_{cs}r_{cs}}} - r_e, \\ Z_{21}^{BX} &= -\frac{Y_{21}}{Y_{11}Y_{22} - Y_{12}Y_{21} - Y_{11}\frac{j\omega C_{cs}}{1+j\omega C_{cs}r_{cs}}} - r_e, & Z_{22}^{BX} &= \frac{Y_{11}}{Y_{11}Y_{22} - Y_{12}Y_{21} - Y_{11}\frac{j\omega C_{cs}}{1+j\omega C_{cs}r_{cs}}} - r_e. \end{aligned} \quad (3.7)$$

3.3.2 C_{bct} , C_{bex} , C_{bci} , r_c and g_m extraction

For block B_X , we obtain the following Taylor expansion coefficients using symbolic analysis in MATLAB (code is given in Appendix D)

$$\Im \left[1/(Z_{22}^{BX} - Z_{21}^{BX}) \right]_1 = C_{bct}, \quad (3.8)$$

$$\Re \left[1/(Z_{22}^{BX} - Z_{21}^{BX}) \right]_2 = C_{bct}^2 \left(r_c - \gamma r_{bi} \frac{C_{bex} + C_{bex}}{C_{bct}} \right), \quad (3.9)$$

$$\Re \left[1/Z_{12}^{BX} \right]_0 = g_m. \quad (3.10)$$

The basic idea is that r_{bx} does not impact the above Z-parameters. Therefore, the coefficients are not affected by r_{bx} . C_{bct} can be directly obtained from (3.8), which essentially is the method reported in [66]. With C_{bct} and γ known, C_{bex} and C_{bci} are obtained. g_m can be directly obtained from (3.10). r_c can be extracted from (3.9) by neglecting the term related to small γ as

$$r_c \approx \frac{\Re \left[1/(Z_{22}^{BX} - Z_{21}^{BX}) \right]_2}{C_{bct}^2}. \quad (3.11)$$

Note that (3.11) is sensitive to substrate network de-embedding. Inaccurate C_{cs} and r_{cs} will result in unphysical bias dependence of r_c . Now the Z-parameters of block B_M can be obtained

$$Z_{11}^{BM} = Z_{11}^{BX}, \quad Z_{12}^{BM} = Z_{12}^{BX}, \quad Z_{21}^{BM} = Z_{21}^{BX}, \quad Z_{22}^{BM} = Z_{22}^{BX} - r_c. \quad (3.12)$$

Consequently, the Y-parameters of block B_M are known.

3.3.3 r_{bx} and r_{bi} extraction

Fig. 3.6 shows the block B_M of the small signal equivalent circuit. We have the following

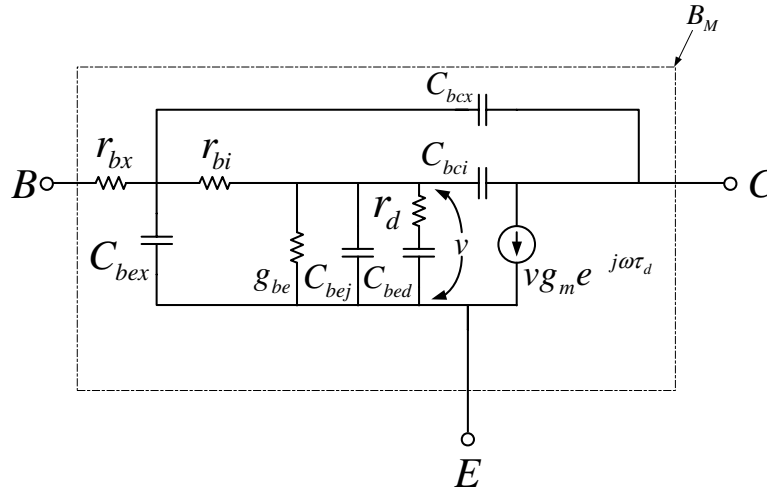


Figure 3.6: Small signal equivalent circuit of SiGe HBTs for block B_M .

Taylor expansion coefficients for block B_M using symbolic analysis

$$\Im(Y_{11}^{BM} + Y_{12}^{BM})_1 \approx C_{bet} + C_{bex}, \quad (3.13)$$

$$\begin{aligned} \Im(Y_{21}^{BM} - Y_{12}^{BM})_1 \approx & g_m \{ (r_{bx} + r_{bi})(C_{bet} + C_{bex}) \\ & + [\tau_d + (r_{bx} + \gamma r_{bi})C_{bct} - r_{bi}C_{bex}] \}, \end{aligned} \quad (3.14)$$

$$\Im(Y_{22}^{BM})_1 \approx C_{bct} + g_m C_{bet} (r_{bx} + \gamma r_{bi}). \quad (3.15)$$

Approximation $(r_{bx} + r_{bi})g_{be} \ll 1$ is used, meaning that these expressions are less accurate at high biases. For SiGe HBTs, due to high base doping, this approximation is valid for low and medium biases, where we extract r_{bx} . According to (3.13) and (3.14), we have

$$\frac{\Im(Y_{21}^{BM} - Y_{12}^{BM})_1}{g_m} \approx (r_{bx} + r_{bi})\Im(Y_{11}^{BM} + Y_{12}^{BM})_1 + U, \quad (3.16)$$

where $U \equiv \tau_d + (r_{bx} + \gamma r_{bi})C_{bct} - r_{bi}C_{bex}$ is bias independent at low biases since all the parameters involved are bias independent at low biases. Fig. 3.7 plots $\Im(Y_{21}^{BM} - Y_{12}^{BM})_1/g_m$ versus $\Im(Y_{11}^{BM} + Y_{12}^{BM})_1$. A linear relation is observed. $r_{bx} + r_{bi}$ is determined by the slope of fitting line according to (3.16). According to (3.15), if we plot $\Im(Y_{22}^{BM})_1$ versus $g_m C_{bct}$, a linear relation can be obtained

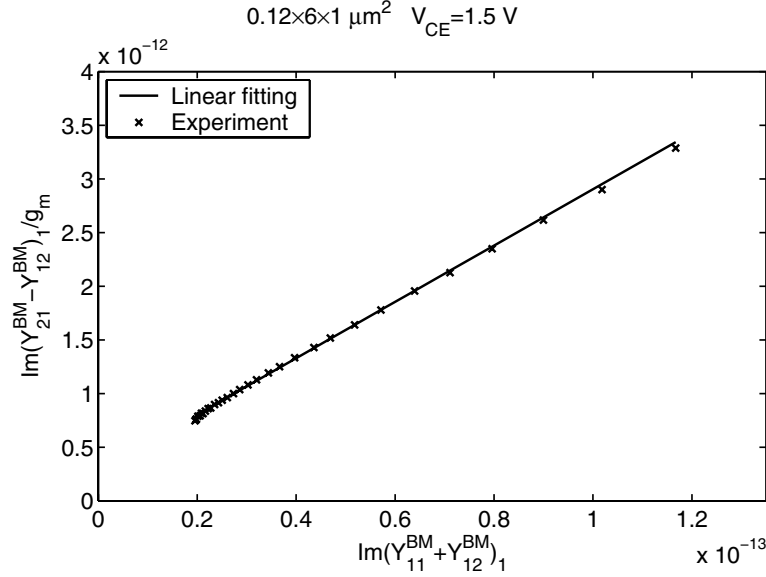


Figure 3.7: $\Im(Y_{21}^{BM} - Y_{12}^{BM})_1/g_m$ versus $\Im(Y_{11}^{BM} + Y_{12}^{BM})_1$. The slope of fitting line gives $r_{bx} + r_{bi}$.

as shown in Fig. 3.8. The slope gives $r_{bx} + \gamma r_{bi}$. With γ known, r_{bx} and r_{bi} can then be calculated from $r_{bx} + \gamma r_{bi}$ and $r_{bx} + r_{bi}$.

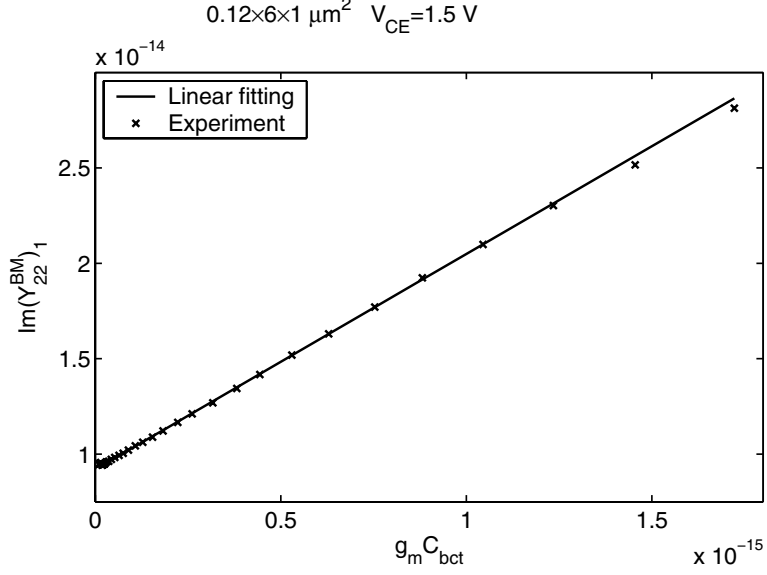


Figure 3.8: $\Im(Y_{22}^{BM})_1$ versus $g_m C_{bct}$. The slope of fitting line gives $r_{bx} + \gamma r_{bi}$.

3.3.4 C_{bex} and C_{bej} extraction

As C_{bej} is the low current limit of C_{bet} , the low current limit of $\Im(Y_{11}^{BM} + Y_{12}^{BM})_1$ gives $C_{bex} + C_{bej}$ according to (3.13). For block B_M , we have

$$\begin{aligned} \Re(Y_{11}^{BM} + Y_{12}^{BM})_2 &\approx r_{bx}(C_{bej} + C_{bex})(C_{bej} + C_{bex} + C_{bct}) \\ &\quad + r_{bi}C_{bej}^2 + (\gamma r_{bi}C_{bct})C_{bej} + g_m W, \end{aligned} \quad (3.17)$$

where W is a complex function of circuit parameters. Again $(r_{bx} + r_{bi})g_{be} \ll 1$ is used. Consider now the low current limit of (3.17),

$$\begin{aligned} \{r_{bi}\}C_{bej}^2 + \{(\gamma r_{bi}C_{bct})\}C_{bej} + \{r_{bx}(C_{bej} + C_{bex})(C_{bej} + C_{bex} + C_{bct}) \\ - \Re(Y_{11}^{BM} + Y_{12}^{BM})_2|_{g_m \rightarrow 0}\} = 0. \end{aligned} \quad (3.18)$$

This is a quadratic equation for C_{bej} with all the coefficients in the curly brackets known. C_{bej} corresponds to the positive root. C_{bex} is then obtained.

To extract the low current limits for Taylor expansion coefficients, $\Im(Y_{11}^{BM} + Y_{12}^{BM})_1$ and $\Re(Y_{11}^{BM} + Y_{12}^{BM})_2$, we make a linear fitting versus g_m within *low current* domain for these coefficients. The y-axis intercepts give the corresponding low current limits. Fig. 3.9 illustrates the low current limit extraction of $\Re(Y_{11}^{BM} + Y_{12}^{BM})_2$ and $\Im(Y_{11}^{BM} + Y_{12}^{BM})_1$.

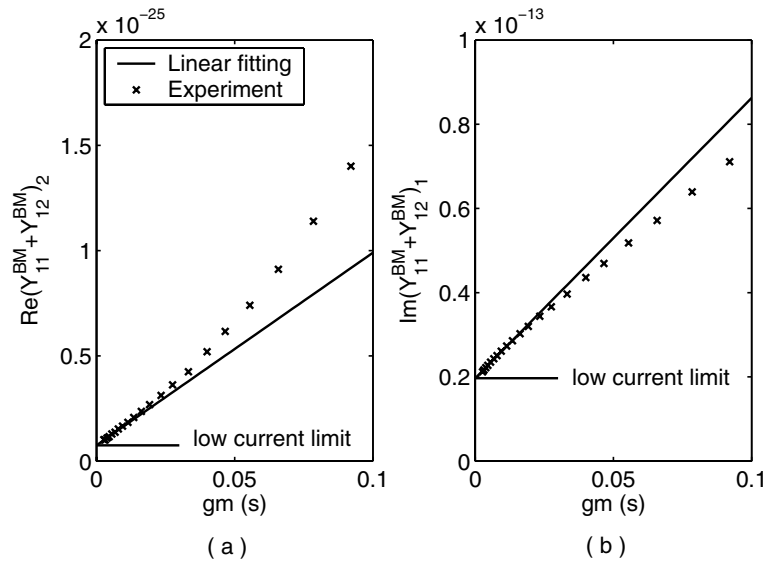


Figure 3.9: Illustration of low current limit extraction for (a) $\Re(Y_{11}^{BM} + Y_{12}^{BM})_2$, and (b) $\Im(Y_{11}^{BM} + Y_{12}^{BM})_1$.

So far we have extracted all the extrinsic parameters and intrinsic parameter r_{bi} . The Y-parameters of block B_{IR} can be obtained as

$$\begin{aligned} Y_{11}^{BIR} &= \frac{Y_{11}^{BM}}{1 - r_{bx}Y_{11}^{BM}} - j\omega(C_{bex} + C_{bcx}), & Y_{12}^{BIR} &= \frac{Y_{12}^{BM}}{1 - r_{bx}Y_{11}^{BM}} + j\omega C_{bcx}, \\ Y_{21}^{BIR} &= \frac{Y_{21}^{BM}}{1 - r_{bx}Y_{11}^{BM}} + j\omega C_{bcx}, & Y_{22}^{BIR} &= \frac{Y_{12}^{BM} - r_{bx}(Y_{11}^{BM}Y_{22}^{BM} - Y_{12}^{BM}Y_{21}^{BM})}{1 - r_{bx}Y_{11}^{BM}} - j\omega C_{bcx}, \end{aligned} \quad (3.19)$$

which can be transformed into Z-parameters. The Z-parameters of the intrinsic transistor, block B_I , are

$$Z_{11}^{BI} = Z_{11}^{BIR} - r_{bi}, \quad Z_{12}^{BI} = Z_{12}^{BIR}, \quad Z_{21}^{BI} = Z_{21}^{BIR}, \quad Z_{22}^{BI} = Z_{22}^{BIR}. \quad (3.20)$$

Consequently, the Y-parameters of block B_I are now known.

3.3.5 C_{bed} , r_d , g_{be} and τ_d extraction

The Y-parameter Taylor expansion coefficients of block B_I are obtained as

$$\Im(Y_{11}^{BI} + Y_{12}^{BI})_1 = C_{bet}, \quad \Im(Y_{21}^{BI} - Y_{12}^{BI})_1 = g_m\tau_d, \quad (3.21)$$

$$\Re(Y_{11}^{BI})_0 = g_{be}, \quad \Re(Y_{11}^{BI})_2 = C_{bed}\tau_{in}. \quad (3.22)$$

These expressions are accurate for all biases because the factor $(r_{bx} + r_{bi})g_{be}$ does not exist any more.

C_{bet} is given by $\Im(Y_{11}^{BI} + Y_{12}^{BI})_1$. Strictly speaking, C_{bed} can be directly calculated from $C_{bet} - C_{bej}$ as C_{bej} is known. This is, however, not accurate for low biases where $C_{bed} < C_{bej}$. For these biases, we make a linear fitting for C_{bet} versus g_m . The slope gives low bias τ_{tr} . C_{bed} is evaluated by $g_m\tau_{tr}$. C_{bej} is then updated as $C_{bet} - C_{bed}$. Fig. 3.10 (a) illustrates the splitting

procedure for low bias. Clearly τ_{tr} , indicated by the curve slope, increases for the biases after f_T roll off due to Kirk effect. Fig. 3.10 (b) shows the extracted C_{bed} and C_{bej} .

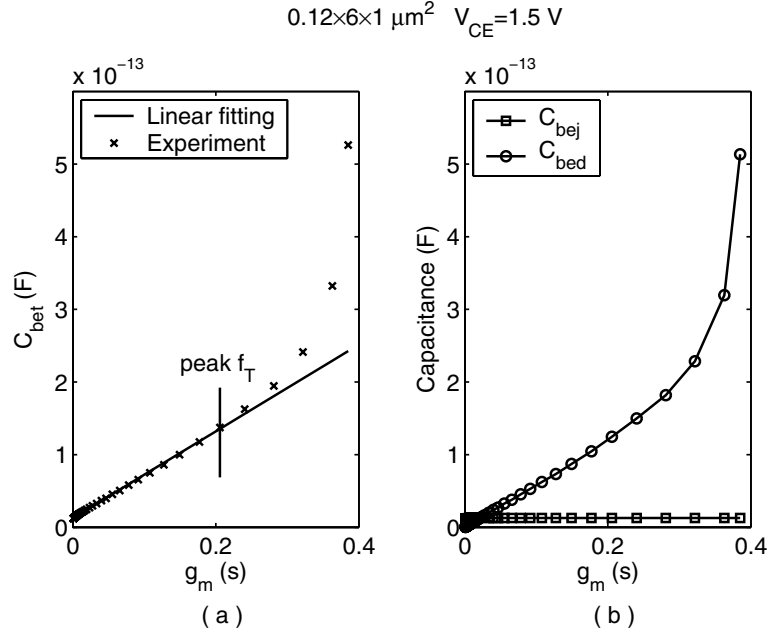


Figure 3.10: Illustration of C_{bet} splitting: (a) Linear fitting for C_{bet} versus g_m ; (b) Extracted C_{bed} and C_{bej} versus g_m .

With C_{bet} split, τ_{in} can be calculated from $\Re(Y_{11}^{BI})_2 / C_{bed}$. r_d is then obtained from τ_{in} / C_{bed} .

Fig. 3.11 shows the extracted r_d versus $1/I_C$. The resulting curve is linear at low biases where τ_{in} is a constant.

The MATLAB program of small signal parameter extraction for the above illustration device is not attached in this dissertation, instead, the similar program for a 50 GHz SiGe HBT is given in Appendix E, since the data of the same device is used to illustrate noise de-embedding in Chapter 4.

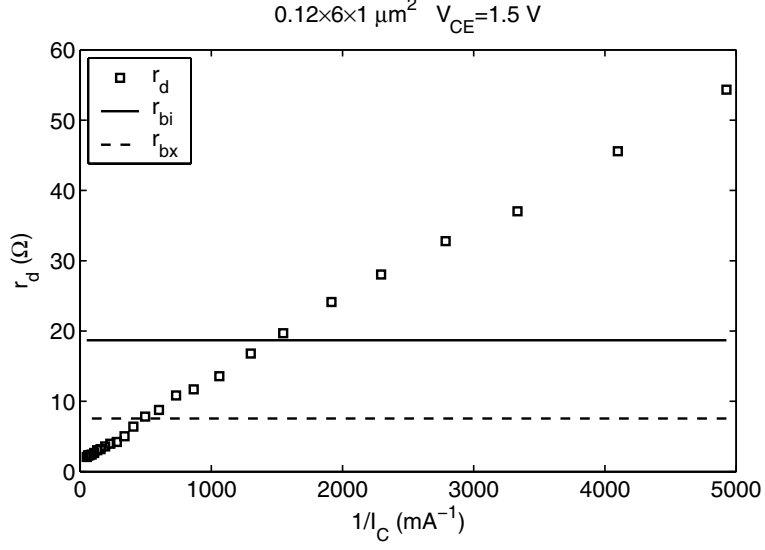


Figure 3.11: Extracted r_d versus $1/I_C$. r_{bx} and r_{bi} are shown for reference.

3.4 Results and discussions

3.4.1 Extraction and modeling results

Table 4.1 summarizes the extracted small signal parameters for the $A_E = 0.12 \times 6 \times 1 \mu\text{m}^2$ SiGe HBTs at three V_{BE} , representing low, medium and high biases, respectively. Fig. 3.12 shows the Y-parameters for both experimental data and simulation results at $V_{BE}=0.921$ V. Excellent fitting has been obtained up to 50 GHz.

3.4.2 Discussions

Fig. 3.13 shows the frequency dependence of intrinsic $\Re(Y_{11}^{BI})$ at three biases for both extracted and modeling results. $\Re(Y_{11}^{BI})$ increases versus frequency. Such frequency dependence cannot be modeled for an equivalent circuit without including input NQS effect.

Table 3.1: Extracted small signal parameter values of $A_E = 0.12 \times 6 \times 1 \mu m^2$ SiGe HBT

V_{CE} (V)	1.5	1.5	1.5
V_{BE} (V)	0.828	0.867	0.921
I_C (mA)	0.44	1.7	7.7
I_B (μ A)	0.0	4.0	46
f_T (GHz)	60.1	127	183
r_{bx} (Ω)	7.56	7.56	7.56
r_{bi} (Ω)	18.7	18.7	18.7
r_e (Ω)	4.0	4.0	4.0
r_c (Ω)	7.2	7.2	7.2
r_d (Ω)	28.0	8.76	3.04
r_{cs} (k Ω)	1.8	1.8	1.8
g_{be} (mS)	0.0572	0.257	1.81
g_m (S)	0.0163	0.0554	0.206
τ_d (ps)	0.43	0.40	0.56
C_{bed} (fF)	9.946	32.61	124.6
C_{bej} (fF)	12.74	12.74	12.74
C_{bex} (fF)	7.585	7.585	7.585
C_{bcx} (fF)	7.614	7.646	7.848
C_{bci} (fF)	1.877	1.855	1.912
C_{cs} (fF)	2.380	2.380	2.380

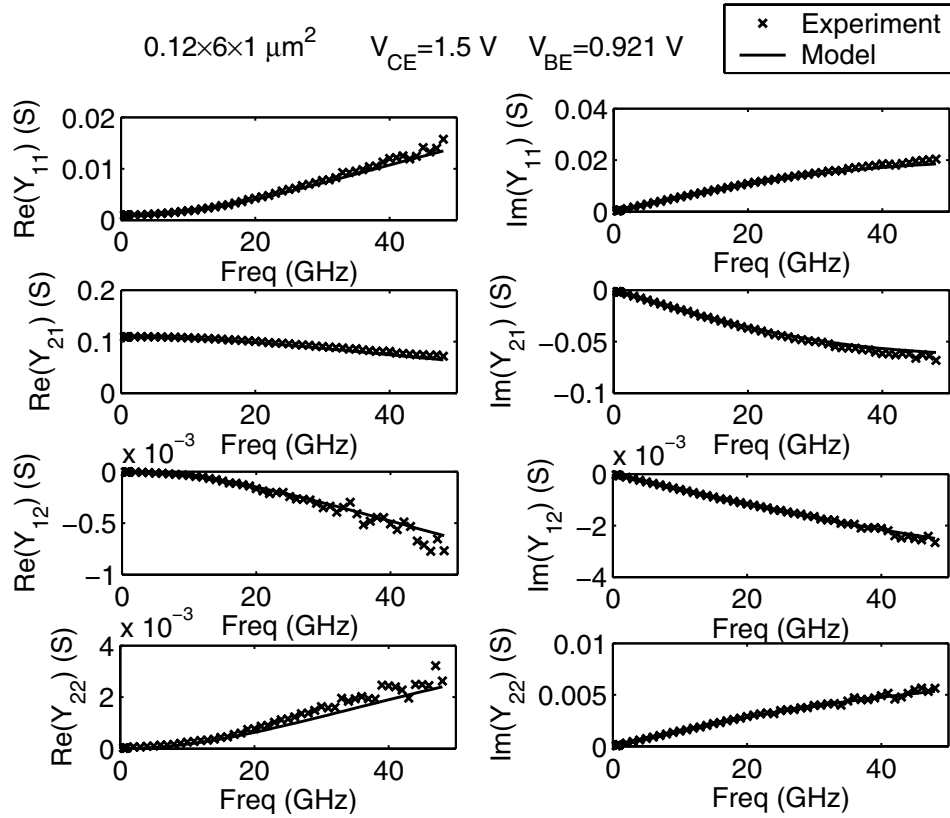


Figure 3.12: Comparison of Y-parameters for experimental data and modeling results at high bias.

The frequency dependence of $\Re(Y_{11}^{BI})$ is important for noise modeling [2, 39]. Fig. 3.14 compares the power spectrum density of intrinsic base current noise S_{ib} obtained from noise de-embedding of experimental noise data and the S_{ib} from van Vliet model $S_{ib} = 4kT\Re(Y_{11}^{BI}) - 2qI_B$, for a 50 GHz $A_E = 0.24 \times 20 \times 2 \mu\text{m}^2$ SiGe HBT at three biases. r_{bi} of this device is 2.03Ω , while the thermal base resistance, r_{bn} is set to be 3.0Ω for the reasons discussed in [6] and Chapter 5. Clearly S_{ib} is frequency dependent and can be modeled by the frequency dependent $\Re(Y_{11}^{BI})$. We choose a 50 GHz device for illustration because CB SCR has significant impact on 180 GHz device noise, consequently S_{ib} cannot be simply modeled with $4kT\Re(Y_{11}^{BI}) - 2qI_B$ ([5], also Chapter 5).

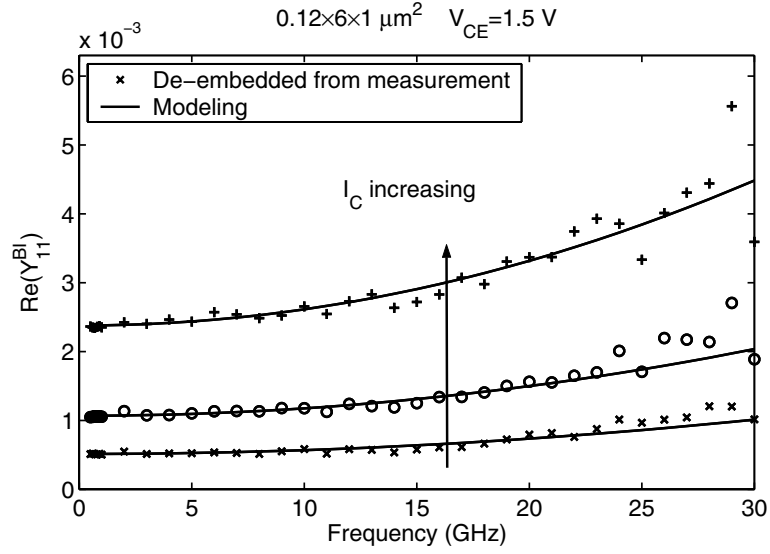


Figure 3.13: Intrinsic $\Re(Y_{11}^{BI})$ extraction and modeling results for three biases.

Fig. 3.15 shows the extracted intrinsic base resistances using equivalent circuit with and without including input NQS effect. $r_{bi,QS}$ is extracted from the Y-parameters of block B_{IR} using circle fitting method [62], which assumes an equivalent circuit *without* including input NQS effect. For the $r_{bi,QS}$ of circle symbol, the Y-parameters of B_{IR} are obtained from experimental data by de-embedding. For the $r_{bi,QS}$ of solid line, the Y-parameters of B_{IR} are calculated using the extracted NQS small signal parameters within B_{IR} . $r_{bi,QS}$ shows a bell-shaped bias dependence that is typical of extraction using an equivalent circuit without input NQS effect. Using a bias-independent r_{bi} (the square symbols), the equivalent circuit including input NQS effect can well reproduce the bias dependence of $r_{bi,QS}$ as shown by the good fitting of solid line to circle symbols. The bias dependence of $r_{bi,QS}$ can be explained by the lumping effect of r_{bi} and r_d , which can be

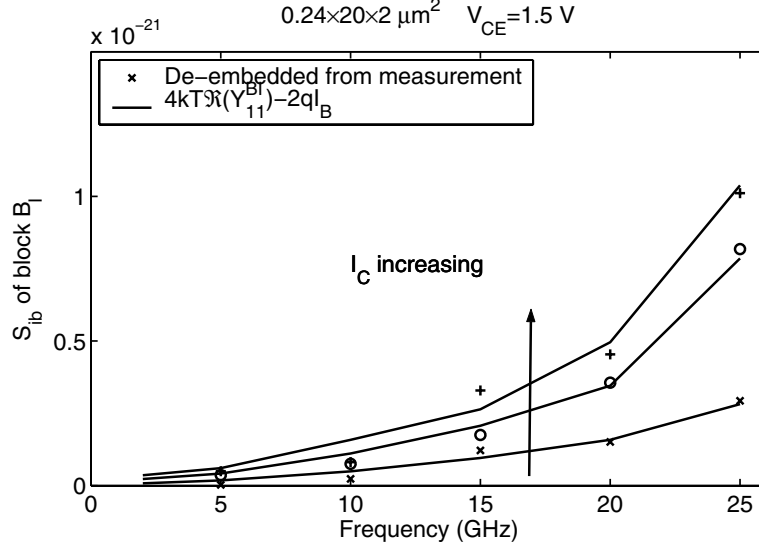


Figure 3.14: Comparison of S_{ib} obtained from noise de-embedding of experimental noise data and van Vliet model $S_{ib} = 4kT\Re(Y_{11}^{BI}) - 2qI_B$ for a 50 GHz $A_E = 0.24 \times 20 \times 2 \mu\text{m}^2$ SiGe HBT at three biases.

approximately described by [4]

$$r_{bi, QS} \approx r_{bi} + r_d C_{bed} \frac{C_{bed}}{(C_{bed} + C_{bej})^2}. \quad (3.23)$$

At low biases $r_d C_{bed} = \tau_{in}$ is a constant [37]. Since C_{bed} increases versus bias and C_{bej} is nearly constant, the ratio $C_{bed}/(C_{bed} + C_{bej})^2$ has a maximum value at $C_{bed} = C_{bej}$. This means that $r_{bi, QS}$ should increase at low biases and drop at high biases. $r_{bi, QS}$ is clearly larger than r_{bi} . The star symbols in Fig. 3.15 show the extracted $r_{bi, QS}$ from experimental data with $C_{bex}=0$. The strong bias dependence of the extraction results suggests the necessity of including C_{bex} in even equivalent circuits without input NQS effect.

Fig. 3.16 shows the extracted delay times. The square represents the effective base transit time τ_{tr} . The down-triangle represents τ_{in} and the up-triangle represents τ_d . The circle represents τ_d extracted using equivalent circuit without including input NQS effect. τ_{tr} is the maximum one as

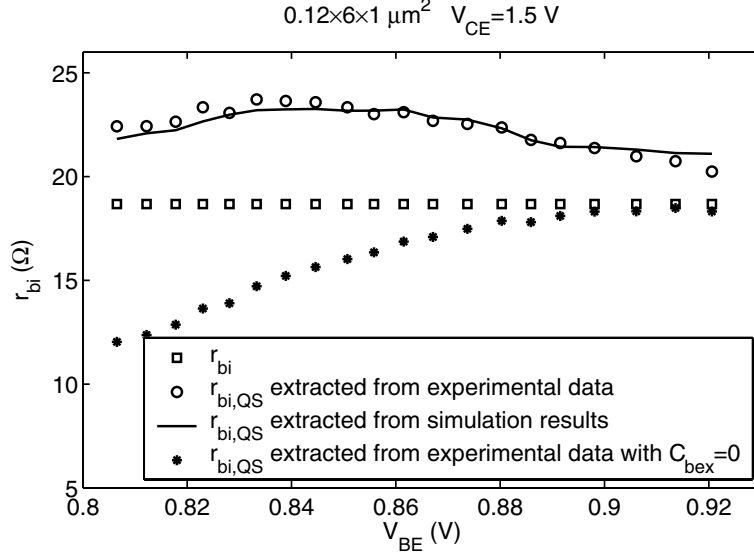


Figure 3.15: Comparison of r_{bi} extracted using equivalent circuit with and without including input NQS effect.

expected by theory in (3.3). It is shown that τ_{tr} , τ_{in} and τ_d are bias independent at low to medium biases and increase dramatically for biases after f_T roll off due to base push out. However, $\tau_{d,QS}$ is strongly bias dependent and non-monotonic for all biases due to the unphysical bias dependence of $r_{bi,QS}$. This further demonstrates that the extracted parameters for the equivalent circuit with input NQS effect are more physical.

3.5 Extraction of bias dependent r_{bi}

In the above sections, we have assumed the bias independence condition for r_{bi} . Such condition is not valid for transistors with lower base doping, e.g. 50 GHz SiGe HBTs. The r_{bi} extracted using the above method, denoted as $\overline{r_{bi}}$, is the approximated r_{bi} value of high bias. That is, we treat $\overline{r_{bi}}$ as initial guess of r_{bi} , which is used to extract r_{bx} and C_{bex} . To obtain bias dependent r_{bi} for full bias range, we start from known block B_{JR} . Equivalently speaking, all the parameters outside of

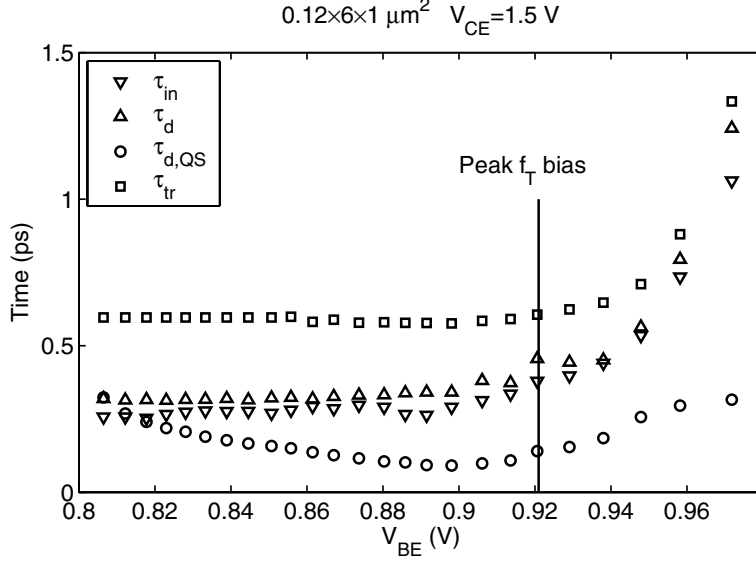


Figure 3.16: Extracted delay times and modeling results for three biases.

block B_{IR} are obtained using the above extraction method. We have

$$\Im \left[\frac{Y_{11}^{BIR} + Y_{12}^{BIR}}{Y_{21}^{BIR} - Y_{12}^{BIR}} \right]_1 = \frac{C_{bed} + C_{bej}}{g_m}, \quad (3.24)$$

$$\Re \left[\frac{Y_{11}^{BIR} + Y_{12}^{BIR}}{Y_{21}^{BIR} - Y_{12}^{BIR}} \right]_2 = \frac{\tau_d C_{bej} + (\tau_d - \tau_{in}) C_{bed}}{g_m}. \quad (3.25)$$

The total EB capacitance can be extracted using (3.24). C_{bed} and C_{bej} can be obtained using the splitting method in Section 3.3.5. Then $\tau_{tr} = C_{bed}/g_m$ for all biases.

Extraction of NQS delay time τ_{in} and τ_d

We first extract the τ_{in} , τ_d values at low to medium biases, where they are constants. We plot $g_m \Re \left[\frac{Y_{11}^{BIR} + Y_{12}^{BIR}}{Y_{21}^{BIR} - Y_{12}^{BIR}} \right]_2$ versus C_{bed} , the curve should be linear at low to medium biases, as shown in Fig. 3.17 for a 50 GHz SiGe HBT. The y-axis intercept gives $\tau_d C_{bej}$ and the slope gives $\tau_d - \tau_{in}$. Consequently both τ_{in} and τ_d values at low to medium biases are obtained. Now we assume that the ratios τ_{in}/τ_{tr} and τ_d/τ_{tr} are bias independent and can be obtained low bias values of τ_{in} , τ_d and

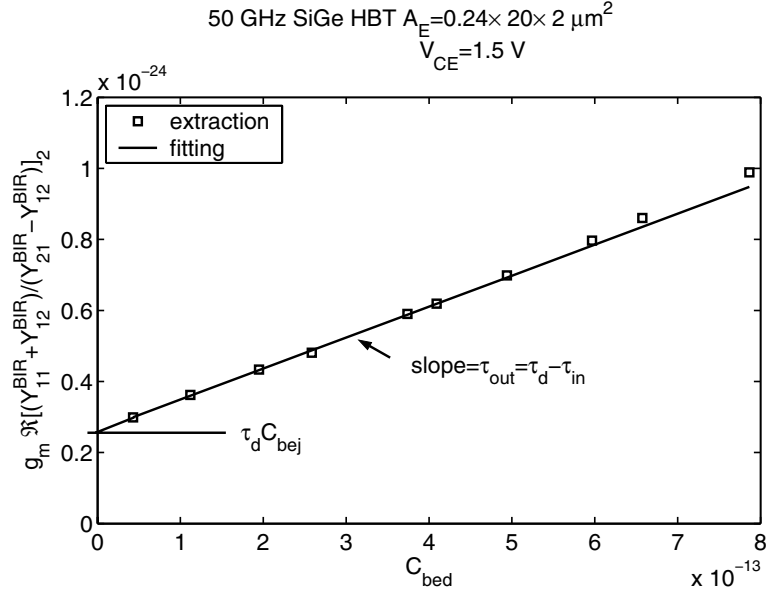


Figure 3.17: NQS delay time (τ_{in} and τ_d or τ_{out}) extraction.

τ_{tr} . The τ_{in} , τ_d values of full bias range are determined by

$$\tau_{in} = \tau_{tr} \left(\frac{\tau_{in}}{\tau_{tr}} \right)_{low}, \quad \tau_d = \tau_{tr} \left(\frac{\tau_d}{\tau_{tr}} \right)_{low}. \quad (3.26)$$

Extraction of bias dependent r_{bi}

So far, the only unknown parameter for the intrinsic device without r_{bi} , or block B_I , is g_{be} .

Note that

$$\Re(Y_{11}^{BI})_0 = \frac{g_{be}}{1 + g_{be}r_{bi}}. \quad (3.27)$$

(3.27) does not give g_{be} since r_{bi} is unknown yet. Here we use the bias independent r_{bi} value extracted in Section 3.3.3, i.e. $\overline{r_{bi}}$. g_{be} then can be calculated as

$$g_{be} = \frac{\Re(Y_{11}^{BI})_0}{1 - \Re(Y_{11}^{BI})_0 \overline{r_{bi}}}. \quad (3.28)$$

Another simple but approximated way to obtain g_{be} is to use I_b/V_T . Now the Y-parameters of block B_I is totally known. r_{bi} can be extracted from the Y_{11} difference between block B_I and B_{IR} , that is

$$r_{bi} = \frac{1}{Y_{11}^{BIR}} - \frac{1}{Y_{11}^{BI}} = \frac{1}{Y_{11}^{BIR}} - \frac{1}{g_{be} + j\omega \left(C_{bci} + C_{bej} + \frac{C_{bed}}{1+j\omega\tau_{in}} \right)}. \quad (3.29)$$

Fig. 3.18 shows the extracted bias dependent r_{bi} compared with $\overline{r_{bi}}$ for (a) 50 GHz SiGe HBT and (b) 180 GHz SiGe HBTs. Since the r_{bi} is significantly bias dependent for the 50 GHz SiGe HBT, the $\overline{r_{bi}}$ has noticeable error as shown in Fig. 3.18 (a). However, for the 180 GHz SiGe HBT, r_{bi} is indeed weakly bias dependent. Consequently, the bias independent r_{bi} extraction method gives accurate value.

3.6 Summary

In this chapter, we have examined small signal equivalent circuit modeling of input NQS effect including CB SCR delay. The input NQS effect is found to be more pronounced in scaled SiGe HBTs with higher built-in field, despite reduced total transit time and reduced absolute value of the input NQS delay time. A new direct parameter extraction method based on Taylor expansion of analytical Y/Z-parameter expressions has been developed and demonstrated for such circuit. The extracted parameters, such as intrinsic base resistance and excess phase delay time, are more physical than using conventional equivalent circuit without including input NQS effect. The frequency

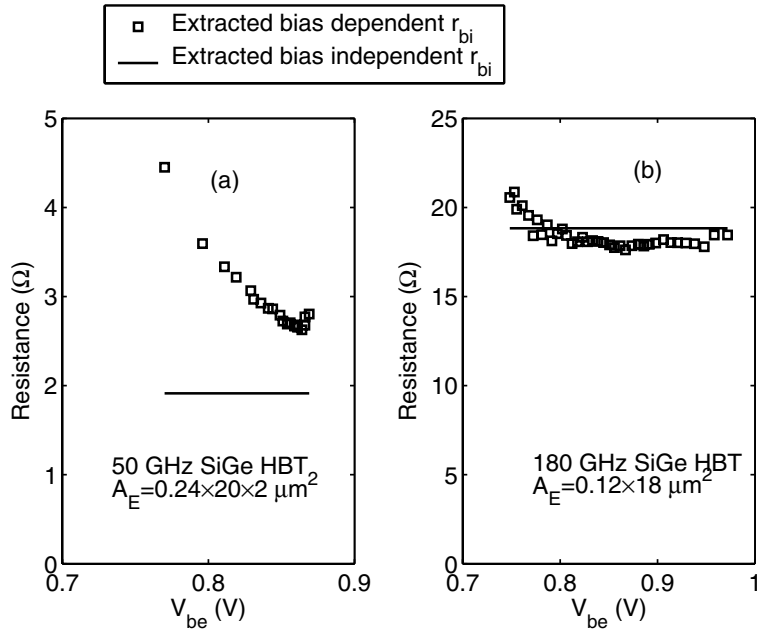


Figure 3.18: Bias dependent r_{bi} compared with $\overline{r_{bi}}$ for (a) 50 GHz SiGe HBT and (b) 180 GHz SiGe HBTs.

dependence of the real part of intrinsic Y_{11} is modeled and describes well the intrinsic base current noise de-embedded from experimental data. The extraction method has been verified for SiGe HBTs from different generations of technology.

CHAPTER 4

SEMI-EMPIRICAL NOISE MODEL BASED ON EXTRACTION

Present noise modeling approaches in current compact bipolar models uses uncorrelated $2qI$ shot noises for base and collector currents, and uses $4kT$ thermal noise for intrinsic base resistance based on QS input equivalent circuit [1]. As discussed in Chapter 2, such scenario is not accurate enough, particularly at the increasingly higher frequencies for robust circuit simulation, and must be refined to enable predictive low-noise RF circuit design. The straightforward and physical way to noise modeling is to propose better model for $S_{i_{rbi}}$ and correlated base and collector current noises using NQS equivalent circuit as done in Chapter 5.

This chapter, however, presents modeling of correlated RF noise in the intrinsic base and collector currents of SiGe HBTs, still using QS equivalent circuits. The purpose is to develop an improved noise model within the frame work of existing CAD tools. We use the improved $S_{i_{rbi}}$ model of (2.77), and then extract intrinsic noise S_{ib} , S_{icib^*} and S_{ic} from device noise parameters using standard noise de-embedding method [54]. We then develop semi-empirical equations to model these noise sources. The number of model parameters is the same as the previous noise modeling method, as we need in general four numbers to describe a noise correlation matrix. However, the S_{ib} and S_{ic} obtained are in general positive, which is an improvement over the previous method. The deviation caused by the use of a QS input equivalent circuit, and hence the lumping of input NQS resistance into r_{bi} , as well as the use of the improved $S_{i_{rbi}}$ model, is lumped into the intrinsic noise. The extracted S_{ib} and S_{ic} are thus not exactly the physical intrinsic transistor noises, which can only be obtained through higher order modeling that includes input NQS and noise crowding effects. The noise sources and their correlation, are first modeled as functions of

frequency (ω). The coefficients are then extracted and modeled as a function of biasing current through g_m , as detailed below. The model is shown to work at frequencies up to at least half of the peak f_T , and at biasing currents below high injection f_T roll off for devices with different emitter geometries.

In the following, we present the intrinsic noise de-embedding technique, the semi-empirical intrinsic noise model, geometry scaling ability, and model implementation in CAD tools.

4.1 Intrinsic noise extraction

4.1.1 Two basic noise de-embedding techniques

In Chapter 1, we introduced four two-port noise representations. For the case of SiGe HBT, only impedance (Z-) and admittance (Y-) representations are needed for noise de-embedding as shown below.

- Series block de-embedding

In Fig. 4.1, block N is in series with block A, B and C. Denote the final block as N' . The noise voltage of block A, B and C can be calculate by $4kT$ multiplied with the real part of Z-parameter of each block. If the noises of both N and N' are in Z-representation, the noise of inner block noise S_N^Z can be calculated from total block noise by

$$S_N^Z = S_{N'}^Z - 4kT \begin{bmatrix} \Re(Z_A + Z_C) & \Re(Z_C) \\ \Re(Z_C) & \Re(Z_B + Z_C) \end{bmatrix}, \quad (4.1)$$

where Z_A , Z_B and Z_C denote the impedances of block A, B and C respectively.

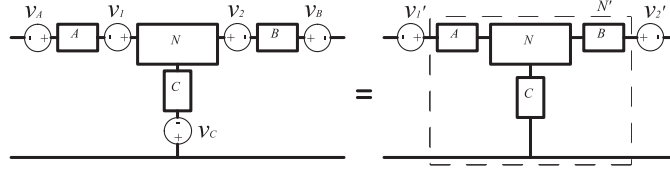


Figure 4.1: Series block de-embedding using impedance representation.

It is worth to note the Z-parameter de-embedding here:

$$Z_N = Z_{N'} - \begin{bmatrix} Z_A + Z_C & Z_C \\ Z_C & Z_B + Z_C \end{bmatrix}. \quad (4.2)$$

- Parallel block de-embedding

In Fig. 4.2, block N is paralleled with Block A, B and C. The final block is denoted as N' .

The noise current of block A, B and C can be calculate by $4kT$ multiplied with the real part of Y-parameter of each block. If the noises of both N and N' are in Y-representation, the noise of inner block noise S_N^Y can be calculated from total block noise by

$$S_N^Y = S_{N'}^Y - 4kT \begin{bmatrix} \Re(Y_A + Y_C) & -\Re(Y_C) \\ -\Re(Y_C) & \Re(Y_B + Y_C) \end{bmatrix}, \quad (4.3)$$

where Y_A , Y_B and Y_C denote the admittances of block A, B and C respectively.

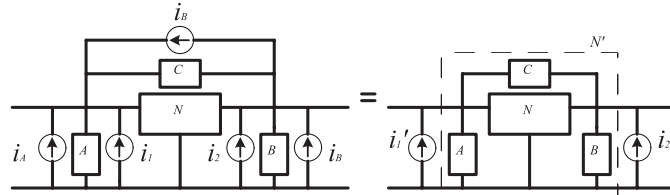


Figure 4.2: Parallel block de-embedding using admittance representation.

It is also worth to note the Y-parameter de-embedding for parallel configuration:

$$Y_N = Y_{N'} - \begin{bmatrix} Y_A + Y_C & -Y_C \\ -Y_C & Y_B + Y_C \end{bmatrix}. \quad (4.4)$$

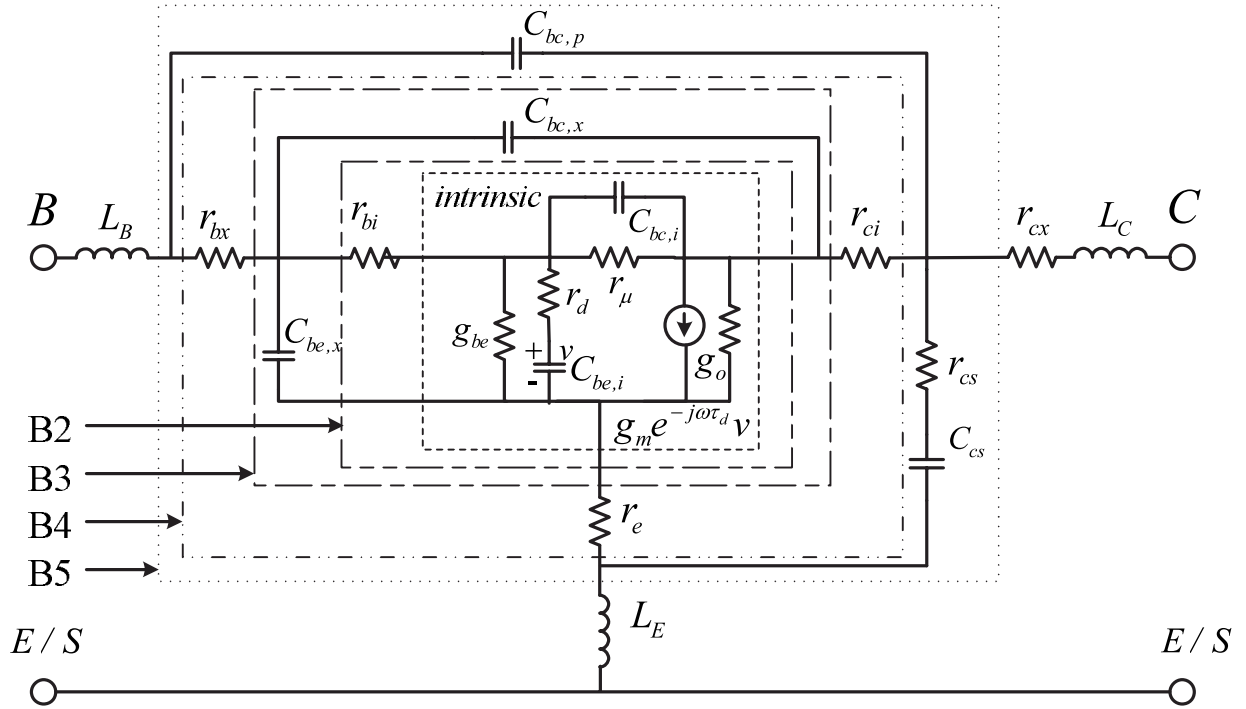
4.1.2 SiGe HBT noise calculation

Fig. 4.3 shows the complete QS small signal equivalent circuit used in noise de-embedding. In our calculation, $C_{bc,p}$ is set to be zero. For the sake of convenience, we define six blocks (B1-B6) as shown in Fig. 4.3:

- B6: just the device under test.
- B5: exclude L_B , L_C , L_E and r_{cx} from B6.
- B4: exclude $C_{bc,p}$, C_{cs} and r_{cs} from B5.
- B3: exclude r_{bx} , r_{ci} and r_e from B4.
- B2: exclude $C_{be,x}$ and $C_{bc,x}$ from B3.
- B1: exclude r_{bi} from B2. It is designated as the "intrinsic" transistor, which stands for the ideal 1-D transistor without intrinsic base resistance.

Based on these definitions, the noise de-embedding procedure is described below. Note that the noise calculation for whole transistor is exactly the inverse of noise de-embedding.

- STEP 1: Calculate the noise matrix of B6 in Z-representation from DUT noise parameters. De-embed L_B , L_C , L_E and r_{cx} , which leads to the Z-representation noise matrix of B5.
- STEP 2: Transform Z-representation into Y-representation for B5. De-embed $C_{bc,p}$, C_{cs} , and r_{cs} . The Y-representation noise matrix of B4 is obtained.



B1 = Intrinsic
 B6 = Device Under Test

Figure 4.3: Small signal equivalent circuit of SiGe HBT used for Y-parameter and noise parameters de-embedding.

- STEP 3: Transform Y-representation into Z-representation for B4. De-embed r_{bx} , r_{ci} , and r_e . This gives Z-representation noise matrix of B3.
- STEP 4: Transform the Z-representation into Y-representation for B3. De-embed $C_{be,x}$ and $C_{bc,x}$ leading to the Y-representation noise matrix of B2.
- STEP 5: Transform Y-representation into Z-representation for B2. De-embed r_{bi} . As a consequence, the Z-representation noise matrix of intrinsic transistor is obtained. For convenience in intrinsic noise modeling, the Z-representation is transformed into Y-representation.

The MATLAB program for Y-parameter and noise de-embedding is shown in Appendix F.

4.1.3 Extracted intrinsic noise

S-parameters and noise parameters are measured for SiGe HBTs of different emitter geometries from a 50 GHz peak f_T process, including $A_E = 0.24 \times 20 \times 2\mu\text{m}^2$, $A_E = 0.24 \times 20 \times 1\mu\text{m}^2$, $A_E = 0.24 \times 10 \times 2\mu\text{m}^2$ and $A_E = 0.48 \times 10 \times 1\mu\text{m}^2$. The data of $A_E = 0.24 \times 20 \times 2\mu\text{m}^2$ device is shown in Appendix F. These geometries allow us to investigate emitter length, width and finger number scaling. Unless specified, the experimental data of the $A_E = 0.24 \times 20 \times 2\mu\text{m}^2$ device is used below for illustration of model derivation. Noise simulation data for a $0.5 \times 1 \times 1\mu\text{m}^2$ SiGe HBT with 30 GHz peak f_T is also used for extraction to provide guidance to model equation development. The SiGe HBT structure used in simulation does not correspond to the measured HBTs.

The S-parameters are measured on-chip using a 8510C Vector Network Analyzer (VNA) from 2-26 GHz. The noise parameters are measured using an ATN NP5 system from 2-25 GHz. Both S-parameters and noise parameters are de-embedded with the standard OPEN structure. The measurement is made across a wide biasing current range up to the peak f_T point. The noise simulation is performed using DESSIS [67].

For a given bias, we first determine the equivalent circuit parameters from measured S-parameters using the direct extraction method in Chapter 3. Note that r_{bi} is extracted using the input impedance circle fitting method with the Y-parameters of the equivalent circuit that consists of r_{bi} and block B1 in Fig. 4.3. The same r_{bi} is used for all noise models. Excellent fitting of measured S-parameters is achieved across a wide biasing current range for all of the frequencies measured. The extracted biasing dependence of equivalent circuit parameters is consistent with device physics based expectations. Table 4.1 gives the equivalent circuit parameter extraction results. Three biases representing low, medium and high biasing currents are shown. The extracted τ_d value is not strictly monotonous, but the variation is small. The extraction of τ_d at low biases is difficult because of the small values of the intrinsic $\Im(Y_{21})$. C_{cs} is bias independent as V_{CE} is fixed

Table 4.1: Extracted small signal parameter values of $0.24 \times 20 \times 2\mu\text{m}^2$ SiGe HBT

	$V_{CE}=1.5\text{V}$ $I_C=4.9\text{mA}$ $I_B=28\mu\text{A}$	$V_{CE}=1.5\text{V}$ $I_C=9.7\text{mA}$ $I_B=66\mu\text{A}$	$V_{CE}=1.5\text{V}$ $I_C=17.9\text{mA}$ $I_B=124\mu\text{A}$
$r_{bx}(\Omega)$	2.70	2.70	2.70
$r_{bi}(\Omega)$	3.20	2.89	2.66
$r_e(\Omega)$	0.63	0.63	0.63
$r_c(\Omega)$	10.1	10.1	10.1
$r_u(\text{K}\Omega)$	3150	421	139
$g_{be}(\text{S})$	0.0011	0.0025	0.0048
$g_m(\text{S})$	0.1730	0.3649	0.6338
$\tau_d(\text{ps})$	1.010	0.9450	0.9465
$C_{be,i}(\text{pF})$	0.5977	0.8854	1.5424
$C_{bc,x}(\text{fF})$	31.000	31.000	31.000
$C_{bc,i}(\text{fF})$	12.338	12.633	14.604
$C_{CS}(\text{fF})$	16.000	16.000	16.000
$L_B(\text{pH})$	48.0	48.0	48.0
$L_C(\text{pH})$	48.0	48.0	48.0
$L_E(\text{pH})$	11.2	11.2	11.2

in the measurement, leading to a fixed collector-to-substrate junction bias. r_u decreases with bias since the neutral base recombination current modulation by V_{CB} is a strong function of I_C [68]. At frequencies above 1 GHz, the effect of r_u is not significant for either Y-parameters or RF noise.

Using Table 4.1, we find that the $2qI_B/3$ to $4kT/r_{bi}$ ratio is 0.25% at peak f_T point and less at lower biases. The $2qI_B/3$ term in improved $S_{i,rbi}$ model is thus negligible for SiGe HBTs because of the heavily doped base and hence a small r_{bi} , as well as a high β and hence a low I_B .

Next, the noise correlation matrix for the whole transistor, including all of the parasitics, is calculated from measured NF_{min} , Y_{opt} and R_n as described in Chapter 1. The noise correlation matrix for the intrinsic transistor is then determined using noise de-embedding technique. After de-embedding r_{bi} , the PSDs of i_b , i_c and $i_c i_b^*$ are obtained from the Y-representation noise correlation matrix of the intrinsic transistor. Fig. 4.4 shows the extracted intrinsic noise sources together with different noise model fits at $I_C=17.9$ mA. The data marked with circle are the extraction results. The dash line represents the SPICE model, the dot line represents the van Vliet model and the

dash-dot line represents the transport model. The solid line, representing the new model, will be discussed in detail in Section III. Note that the results of van Vliet model are shown only for reference as we use QS equivalent circuit. A few important observations can be made from Fig. 4.4:

- The extracted S_{ib} has a strong frequency dependence and is much larger than $2qI_B$ at high frequencies. The van Vliet model S_{ib} is $2qI_B$, the same as the SPICE model, as the input NQS effect is not explicitly modeled. The transport noise model S_{ib} is fitted to the extraction result with parameter τ_n and overlaps with the new model. Note that τ_n is bias dependent and equals 3.5 ps at $I_C=17.9$ mA.
- For S_{ic} , all models except for the new model give $2qI_C$, and hence overlap with each other. Note that the extracted S_{ic} is larger than $2qI_C$. The excess S_{ic} is not due to avalanche multiplication due to the low V_{CE} . S_{ib} would have also been affected if it was due to avalanche multiplication. The higher than $2qI_C$ value of S_{ic} can be attributed to an simplified base hole model for S_{irbi} .
- The extraction shows a strongly frequency dependent correlation S_{icib^*} , which is assumed to be zero in the SPICE model. The van Vliet model S_{icib^*} shows a frequency dependence due to the excess phase τ_d , but the value is underestimated. The transport model S_{icib^*} improves the frequency dependence a lot. However, its $\Im(S_{icib^*})$ is not well modeled, as τ_n is used to fit S_{ib} only. It is also shown that with only one τ_n , simultaneous fitting of $\Re(S_{icib^*})$ and $\Im(S_{icib^*})$ is difficult.

Fig. 4.4 shows that the extracted intrinsic noise cannot be well described by all the old models. Clearly the new semi-empirical noise model gives the best intrinsic noise. The development of the new model is detailed below.

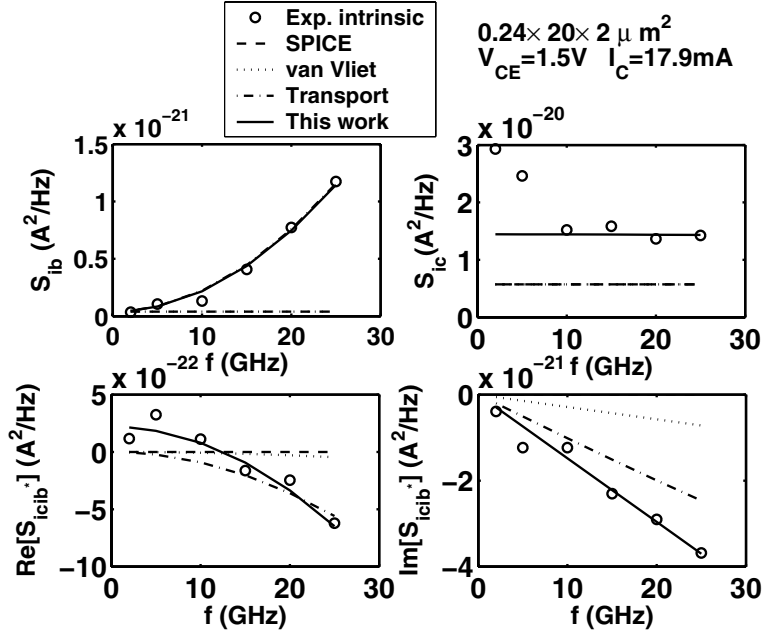


Figure 4.4: Extracted intrinsic noise sources as a function of frequency.

4.2 Semi-empirical intrinsic noise model

Based on the noise source extraction results, we now develop a new noise compact model that is aimed at circuit noise simulation, which requires accurate modeling over both bias and frequency. We will also compare the expressions of the proposed model with other popular models.

4.2.1 S_{ib}

An inspection of the extracted S_{ib} in Fig. 4.4 shows that S_{ib} increases with frequency. At low frequencies, $S_{ib}=2qI_B$, the conventional shot noise. At a given bias, we found that S_{ib} can be expressed as the sum of a shot noise component $2qI_B$ and a frequency dependent component as:

$$S_{ib} = 2qI_B + C_{ib}\omega^2, \quad (4.5)$$

where C_{ib} is a coefficient that varies with bias. At low frequencies, (4.5) reduces into $2qI_B$. In Fig. 4.5 (a), the excess base current noise, defined as $S_{ib} - 2qI_B$, is plotted as a function of ω^2 for two representative biases. The excess base current noise increases with ω^2 in a linear fashion. The data shows that (4.5) works well for all frequencies and biases measured. The $2qI_B$ term is a direct result of emitter hole velocity fluctuation. The $C_{ib}\omega^2$ term is, mainly, a result of base electron velocity and hence current density fluctuations, which induce diffusive capacitive charging, leading to the ω^2 dependence. This is similar to the ω^2 dependence of the induced gate noise in FETs caused by capacitive coupling between gate and channel. The functional form of the new S_{ib} expression can be linked to the S_{ib} expression of the transport noise model, particularly regarding the ω^2 dependence:

$$\begin{aligned}
S_{ib}^{Tran} &= 2qI_B + 4qI_C[1 - \Re(e^{j\omega\tau_n})] \\
&= 2qI_B + 4qI_C[1 - 1 + \frac{\tau_n^2\omega^2}{2} + o(\omega^2)] \\
&\approx 2qI_B + 2qI_C\tau_n^2\omega^2,
\end{aligned} \tag{4.6}$$

where $\omega \ll 1/\tau_n$ is assumed. The ω^2 dependence of the excess S_{ib} can also be shown from the van Vliet model by assuming a first order input NQS model, e.g. the model of Winkel [37]. Using NQS equivalent circuit and noting that g_{be} is approximately equal to $qI_B/(kT)$, one has

$$\begin{aligned}
S_{ib}^{van} &= 4kT\Re(Y_{11}) - 2qI_B \\
&= 4kTg_{be} - 2qI_B + 4kT\Re(Y_{11} - g_{be}) \\
&\approx 2qI_B + 4kTC_{bed}^2r_d\omega^2.
\end{aligned} \tag{4.7}$$

For each bias, the coefficient C_{ib} is extracted by plotting $S_{ib} - 2qI_B$ as a function of ω^2 , as illustrated in Fig. 4.5 (a). A careful inspection of the extracted C_{ib} shows that the biasing

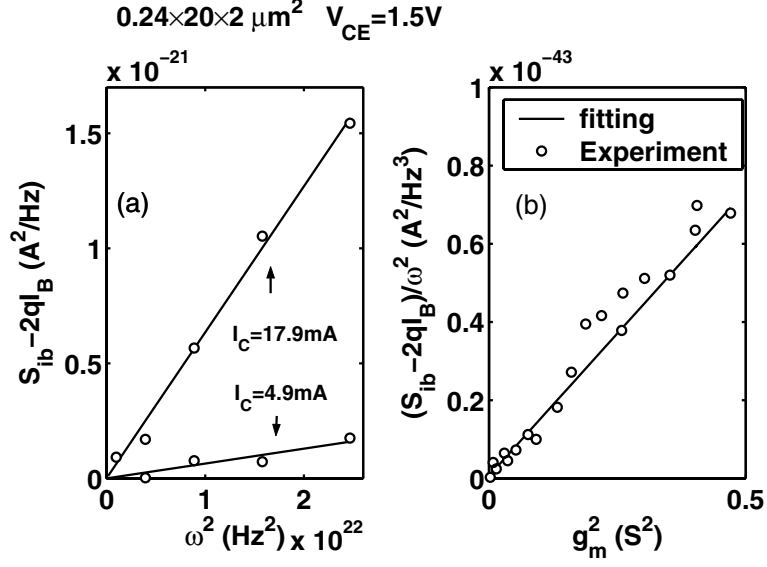


Figure 4.5: (a) $(S_{ib} - 2qI_B)$ versus ω^2 at $I_c = 4.9\text{ mA}$ and 17.9 mA . (b) C_{ib} (denoted as $(S_{ib} - 2qI_B)/\omega^2$) versus g_m .

dependence of C_{ib} can be adequately described through g_m^2 :

$$C_{ib} = K_{bb^*} g_m^2, \quad (4.8)$$

where K_{bb^*} is a bias independent parameter. Fig. 4.5 (b) shows the extracted C_{ib} (denoted as S_{ib}/ω^2) versus g_m^2 . The slope of the fitting line gives K_{bb^*} .

Substituting (4.8) into (4.5) leads to:

$$S_{ib} = 2qI_B + K_{bb^*} g_m^2 \omega^2. \quad (4.9)$$

Equating (4.6) with (4.9) and noticing that g_m is a nearly linear function of I_C , we find that τ_n is bias dependent as shown in [45] and [54]. In the van Vliet model, if we assume that the input NQS delay time $C_{bed}r_d$ is constant, $(S_{ib} - 2qI_B) \propto g_m$, clear different from (4.9).

4.2.2 S_{ic}

In the SPICE model, the van Vliet model and the transport model, S_{ic} is shot like and frequency independent, with a PSD of $2qI_C$. The S_{ic} extracted from both experimental and simulation data, however, indicates that S_{ic} is higher than $2qI_C$ and frequency dependent. Further, the extraction results show that S_{ic} is proportional to the real part of the intrinsic Y_{21} :

$$S_{ic} = C_{ic}\Re(Y_{21}), \quad (4.10)$$

where C_{ic} is a bias dependent coefficient. The frequency dependence of S_{ic} is described by the frequency dependence of $\Re(Y_{21})$. For each bias, C_{ic} is extracted using least square fitting. Fig. 4.6 (a) shows the S_{ic} extracted from measurement data, together with modeling results, at low, medium and high biasing currents. The fitting is not good at low frequencies, as the S_{ic} extraction is less accurate. The main reason is that noise figure is very low at low frequencies, and the system noise plays a bigger role in the noise parameter fitting procedure during measurement. To verify (4.10) without measurement noise problem, we use the simulation data. Very good fitting can be achieved as shown in Fig. 4.7 for all biases and all frequencies up to 30 GHz, the peak f_T .

Fig. 4.6 (b) shows the extracted C_{ic} , denoted as $S_{ic}/\Re(Y_{21})$, as a function of g_m . Note that a linear relation is observed. Thus C_{ic} can be modeled as a function of g_m as

$$C_{ic} = K_{cc^*}g_m + B_{cc^*}, \quad (4.11)$$

where K_{cc^*} and B_{cc^*} are bias independent parameters. The slope and intercept of the fitting line give K_{cc^*} and B_{cc^*} respectively. Substituting (4.11) into (4.10), we obtain the new model equation for S_{ic} as

$$S_{ic} = (K_{cc^*}g_m + B_{cc^*})\Re(Y_{21}). \quad (4.12)$$

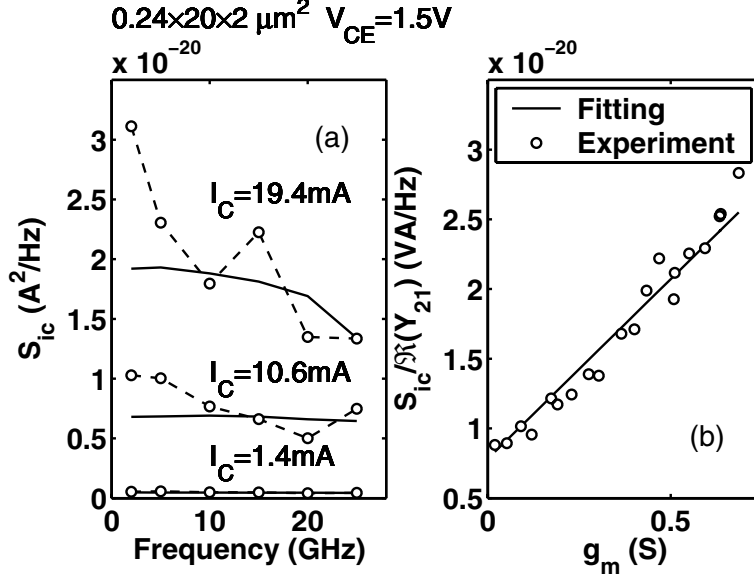


Figure 4.6: (a) Measured S_{ic} versus frequency at $I_c = 1.40$ mA, 10.6 mA and 19.4 mA. (b) C_{ic} (denoted as $S_{ic}/\Re(Y_{21})$) versus g_m .

Note that at low bias S_{ic} reduces to the ideal value $2qI_C$, this indicates that $B_{cc^*} \approx 2kT$. In the van Vliet model, $S_{ic} \approx 2qI_C$ as $\Re(Y_{22})$ is negligible in SiGe HBTs due to high Early voltage. Neither the van Vliet model nor the transport noise model can be used to describe the extracted S_{ic} .

4.2.3 Imaginary part of S_{icib^*} [$\Im(S_{icib^*})$]

Fig. 4.8 (a) plots $\Im(S_{icib^*})$ as a function of ω at representative low and high biasing currents. A linear dependence on ω is observed at all biasing currents. We can thus model $\Im(S_{icib^*})$ as:

$$\Im(S_{icib^*}) = -C_{icib^*}^i \omega, \quad (4.13)$$

where $C_{icib^*}^i$ is a bias dependent coefficient that is determined from the slope of the fitting line. The functional form of (4.13) is consistent with the van Vliet model when $\omega \ll 1/\tau_d$, and consistent

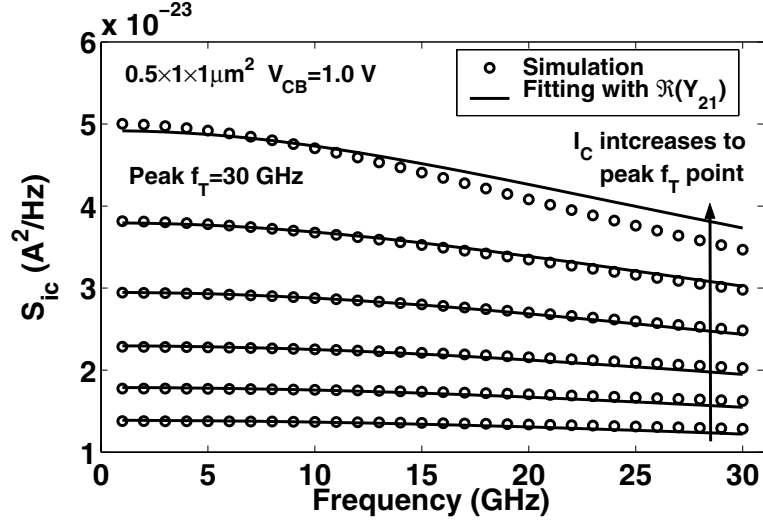


Figure 4.7: Simulated S_{ic} versus frequency at different I_C level.

with the transport noise model when $\omega \ll 1/\tau_n$. In the van Vliet model,

$$\begin{aligned}
 \Im(S_{icib}^{van}) &= \Im[2kT(Y_{21} + Y_{12}^* - g_m)] \\
 &\approx \Im(2kTY_{21}) = \Im(2kTg_m e^{-j\omega\tau_d}) \\
 &\approx -2kTg_m\tau_d\omega.
 \end{aligned} \tag{4.14}$$

In the transport noise model,

$$\begin{aligned}
 \Im(S_{icib}^{tran}) &= \Im[2qI_C(e^{-j\omega\tau_n} - 1)] \\
 &\approx -2qI_C\tau_n\omega.
 \end{aligned} \tag{4.15}$$

The bias dependence of C_{icib}^i extracted from measurement data differs from predictions by both the van Vliet model and the transport noise model. For the van Vliet model, assuming that τ_d

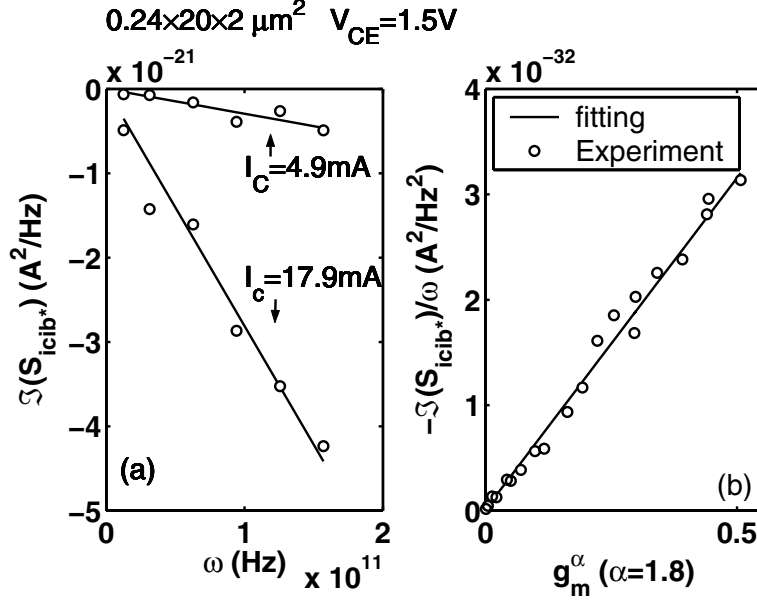


Figure 4.8: (a) $\Im(S_{icib^*})$ versus ω at $I_C=4.9$ mA and 17.9 mA. (b) $C_{icib^*}^i$ (denoted as $\Im(S_{icib^*})/\omega$) versus $g_m^{1.8}$.

is bias independent, an inspection of (4.14) shows that:

$$C_{icib^*}^{i-van} = 2kT g_m \tau_d, \quad (4.16)$$

which is proportional to g_m . For the transport noise model, the bias dependent τ_n gives a more complex bias dependence of $\Im(S_{icib^*})$ according to (4.15).

Fig. 4.8 (b) plots $C_{icib^*}^i$ versus $g_m^{1.8}$. Note that a good linear relation is observed. Thus $C_{icib^*}^i$ can be modeled as a function of biasing current through g_m as:

$$C_{icib^*}^i = K_{cb^*}^i g_m^{1.8}. \quad (4.17)$$

The $C_{icib^*}^i$ in these three cases can be expressed in a single functional form as

$$C_{icib^*}^i = K_{cb^*}^i g_m^{\alpha_{cb^*}^i}, \quad (4.18)$$

where $\alpha_{cb^*}^i$ and $K_{cb^*}^i$ are bias independent parameters. Substituting (4.18) into (4.13), we obtain a new model equation for $\Im(S_{icib^*})$:

$$S_{icib^*} = -(K_{cb^*}^i g_m^{\alpha_{cb^*}^i})\omega. \quad (4.19)$$

4.2.4 Real Part of S_{icib^*} [$\Re(S_{icib^*})$]

Based on the $\Re(S_{icib^*})$ extracted, we model $\Re(S_{icib^*})$ as a linear function of ω^2 as follows:

$$\Re(S_{icib^*}) = C_{icib^*}^{r1} - C_{icib^*}^{r2}\omega^2, \quad (4.20)$$

where $C_{icib^*}^{r2}$ and $C_{icib^*}^{r1}$ are two bias dependent coefficients. Fig. 4.9 shows $\Re(S_{icib^*})$ versus ω^2 at low and high biases respectively. The slope of the fitting line gives $C_{icib^*}^{r2}$ while the intercept gives $C_{icib^*}^{r1}$.

The ω^2 dependence of $\Re(S_{icib^*})$ is consistent with both the van Vliet model and the transport noise model. In the van Vliet model,

$$\begin{aligned} \Re(S_{icib^*}^{van}) &= \Re[2kT(Y_{21} + Y_{12}^* - g_m)] \\ &\approx \Re(g_m e^{-j\omega\tau_d} - g_m) \\ &\approx -2kT g_m \tau_d^2 \omega^2, \end{aligned} \quad (4.21)$$

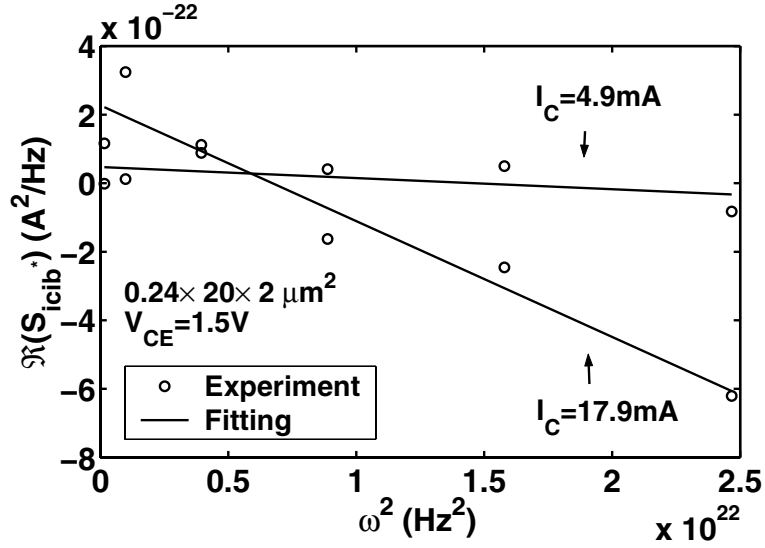


Figure 4.9: $\Re(S_{icib^*})$ versus ω^2 at $I_C=4.9$ mA and 17.9 mA.

which is proportional to ω^2 . In the transport noise model,

$$\begin{aligned} \Re(S_{icib^*}^{tran}) &= \Re[2qI_C(e^{-j\omega\tau_n} - 1)] \\ &\approx -qI_C\tau_n^2\omega^2, \end{aligned} \quad (4.22)$$

which is also proportional to ω^2 . Here $\omega \ll 1/\tau_n$ is assumed. However, the $C_{icib^*}^{r1}$ parameter in (4.20) would be zero for both the van Vliet model and the transport noise model, as can be seen from (4.21) and (4.22).

To model the bias dependence, the $C_{icib^*}^{r2}$ extracted is observed to be a linear function of g_m^2 , as illustrated in Fig. 4.10 (a). Thus $C_{icib^*}^{r2}$ can be modeled as

$$C_{icib^*}^{r2} = K_{cb^*}^{kr} g_m^2, \quad (4.23)$$

where $K_{cb^*}^{kr}$ is a bias independent parameter.

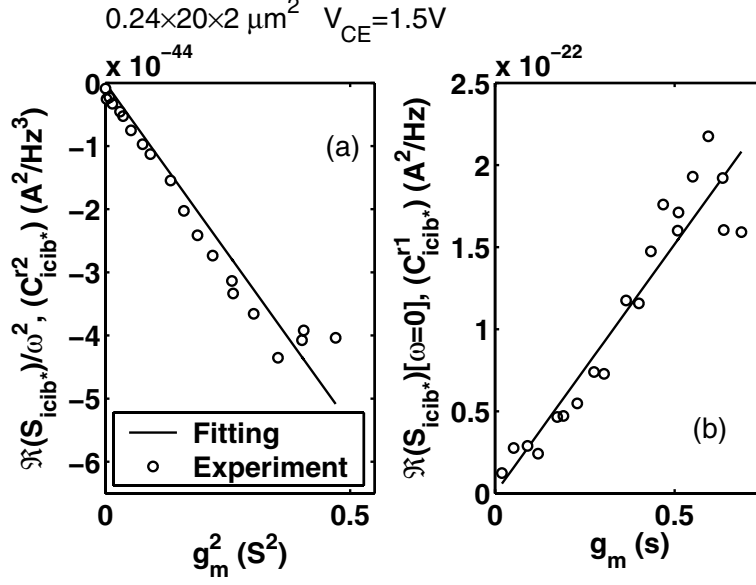


Figure 4.10: (a) $C_{icib^*}^{r2}$ (denoted as $\Re(S_{icib^*})/\omega^2$) versus g_m^2 . (b) $C_{icib^*}^{r1}$ (denoted as $\Re(S_{icib^*})[\omega = 0]$) versus g_m .

Fig. 4.10 (b) shows the extracted $C_{icib^*}^{r1}$ versus g_m . A linear relation is observed, thus $C_{icib^*}^{r1}$ can be modeled as a function of biasing by:

$$C_{icib^*}^{r1} = K_{cb^*}^{br} g_m. \quad (4.24)$$

where $K_{cb^*}^{br}$ is a bias independent parameter.

Substituting (4.23) and (4.24) into (4.20) gives the new model equation for $\Re(S_{icib^*})$:

$$\Re(S_{icib^*}) = K_{cb^*}^{br} g_m - (K_{cb^*}^{kr} g_m^2) \omega^2. \quad (4.25)$$

4.2.5 Generalized Model Equations

So far we have shown that the correlated noise sources extracted from noise measurement data can be well modeled using (4.9), (4.12), (4.19) and (4.25). The modeling results fit the

experimental results well, as can be seen from Fig. 4.4 for $I_C=17.9$ mA. Application of the model equations to measured noise data and microscopic noise simulation data suggests the following generalized model expressions:

$$S_{ib} = 2qI_b + \omega^2(K_{bb^*}g_m^{\alpha_{bb^*}} + B_{bb^*}), \quad (4.26)$$

$$S_{ic} = (K_{cc^*}g_m^{\alpha_{cc^*}} + B_{cc^*})\Re(Y_{21}), \quad (4.27)$$

$$\Re(S_{icib^*}) = K_{cb^*}^{br}g_m - \omega^2 K_{cb^*}^{kr}g_m^2, \quad (4.28)$$

$$\Im(S_{icib^*}) = -\omega(K_{cb^*}^i g_m^{\alpha_{cb^*}^i} + B_{cb^*}^i). \quad (4.29)$$

In general, we found that:

- α_{bb^*} , $\alpha_{cb^*}^i$ is between 1 and 2, and $\alpha_{cc^*} \approx 1$.
- B_{cc^*} can be approximated by $2kT$.
- $\Re(S_{icib^*})$ is less important than other noise terms as detailed below.

(4.26)—(4.29) give a set of model equations with a total of 11 model parameters. The $\Re(S_{icib^*})$ is much less important than $\Im(S_{icib^*})$, we can set $\Re(S_{icib^*})=0$ with only a slight accuracy loss in Y_{opt} at high frequencies as shown below in Section IV. Such a simplification further reduces two parameters. The B_{bb^*} and $B_{cb^*}^i$ parameters are primarily introduced for low bias fitting. Their effects on NF_{min} , R_n and G_{opt} are opposite, therefore in most cases we only need one of these two parameters. B_{bb^*} is used in this work.

So far we have individually examined the extraction results and proposed models for S_{ib} , S_{ic} , $\Re(S_{icib^*})$ and $\Im(S_{icib^*})$. These PSDs, however, according to random process statistics, are not completely independent. Instead, the normalized correlation c , defined as $c \equiv S_{icib^*}/\sqrt{S_{ib}S_{ic}}$, must have a magnitude no larger than unity, i.e. $|c| \leq 1$ [47, 69]. The new model equations do

not guarantee $|c| \leq 1$. Mathematical conditioning can be used during model implementation to ensure $|c| \leq 1$. However, during parameter extraction, this should not be used, as $|c| > 1$ indicates a problem with either noise measurement or equivalent circuit parameter extraction.

Fig. 4.11 (a) shows the real and imaginary part of c versus frequency at $I_C=17.9$ mA. Fig. 4.11 (b) shows the magnitude of c versus frequency at $I_C=17.9$ mA. Fig. 4.11 (c) shows the real and imaginary part of c versus I_C at $f=25$ GHz. Fig. 4.11 (d) shows the magnitude of c versus I_C at $f=25$ GHz. In most cases, $|c| \leq 1$ is satisfied as shown in Fig. 4.11 (b) and (d). Observe that the magnitude of c is close to unity in many cases, therefore the correlation in SiGe HBTs is important and cannot be neglected. Another related observation is that $\Re(c)$ is nearly one order of magnitude smaller than $\Im(c)$ in practice for frequencies less than half of f_T . This is also true for noise simulation results. As a result, $\Re(S_{icib^*})$ is much less important than $\Im(S_{icib^*})$, which is further supported by the sensitivity analysis given below.

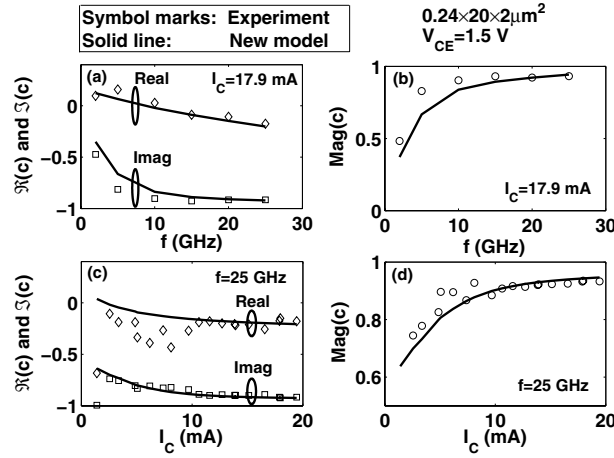


Figure 4.11: Normalized correlation c of the extracted intrinsic noise for $0.24 \times 20 \times 2 \mu m^2$ device: (a) $\Re(c)$ and $\Im(c)$ versus frequency at $I_c=17.9$ mA; (b) Magnitude of c versus frequency at $I_c=17.9$ mA; (c) $\Re(c)$ and $\Im(c)$ versus I_c at $f=25$ GHz; (d) Magnitude of c versus I_c at $f=25$ GHz.

Table 4.2: Parameter values of the simplified noise model for Experiment $0.24 \times 20 \times 2 \mu\text{m}^2$ 50 GHz SiGe HBT .

Parameter	Value	Parameter	Value
α_{bb^*}	2	K_{bb^*}	1.3934×10^{-43}
$\alpha_{cb^*}^i$	1.8	$K_{cb^*}^i$	6.2936×10^{-32}
α_{cc^*}	1	K_{cc^*}	2.5782×10^{-20}
B_{bb^*}	1×10^{-60}	$B_{cb^*}^i$	0
$K_{cb^*}^{br}$	3.0348×10^{-22}	$K_{cb^*}^{kr}$	1.0809×10^{-43}
B_{cc^*}	7.8210×10^{-21}		

4.2.6 Noise Parameter Modeling Results

Using the methods described above, the 11 bias independent noise model parameters are extracted. Table 4.2 lists the parameters values (in MKS units) for the measured $0.24 \times 20 \times 2 \mu\text{m}^2$ SiGe HBT.

Fig. 4.12 shows the modeled and measured noise parameters versus frequency at $I_C=17.9$ mA. $\Re(S_{icib^*})$ is much smaller than $\Im(S_{icib^*})$, making it possible to neglect $\Re(S_{icib^*})$. We thus also calculate the noise parameters with $\Re(S_{icib^*})=0$. The data marked with circle is the measurement. The dash line represents the SPICE model, the solid line represents the new model with $\Re(S_{icib^*})$ and the dash dot line represents the new model with $\Re(S_{icib^*})=0$. Fig. 4.13 shows the noise parameters of the same device as functions of collector current at $f=25$ GHz. It is inconsistent to implement the van Vliet model using a QS equivalent circuit, thus noise parameters are not shown for the van Vliet model. Similarly, the transport noise model result is not shown either due to its limitations in noise source modeling.

Using the proposed new model, excellent fitting is obtained for all of the four noise parameters, at all frequencies and across all biasing currents. Even with $\Re(S_{icib^*})=0$, only Y_{opt} is slightly affected at frequencies above 20 GHz. This is beneficial as we can save two noise model parameters related to $\Re(S_{icib^*})$ by setting $\Re(S_{icib^*})=0$. To quantify errors from using current CAD tools, we

also show results obtained using the SPICE model. At low current level, the SPICE model works well, as was shown in [69]. However, at high current level, NF_{min} , G_{opt} and B_{opt} are overestimated.

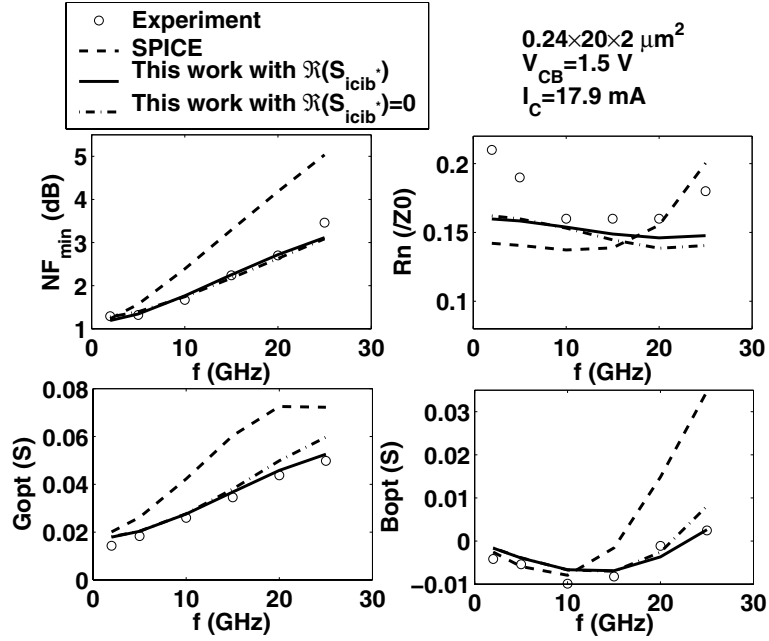


Figure 4.12: Noise parameters versus frequency for the measured noise data. $I_c=17.9$ mA. $A_E=0.24 \times 20 \times 2 \mu m^2$.

So far we have used the $A_E=0.24 \times 20 \times 2 \mu m^2$ device as an example. A natural question is how the noise sources scale with geometry. For ideal scaling, S_{ib} , S_{ic} and S_{icib^*} should all scale with the emitter area A_E for the same biasing current density. This is indeed the case according to the extracted data from various geometries as shown below. Nonideal noise parameter scaling with geometry is mostly from nonideal scaling of resistances, such as r_{bx} and r_{bi} .

4.2.7 Sensitivity Analysis

For understanding of model to data correlation and model parameter extraction, it is useful to calculate the sensitivity of noise parameters (NF_{min} , R_n and Y_{opt}) to the intrinsic noise model parameters. Table 4.3 gives the percentage change of noise parameters responding to 5% change

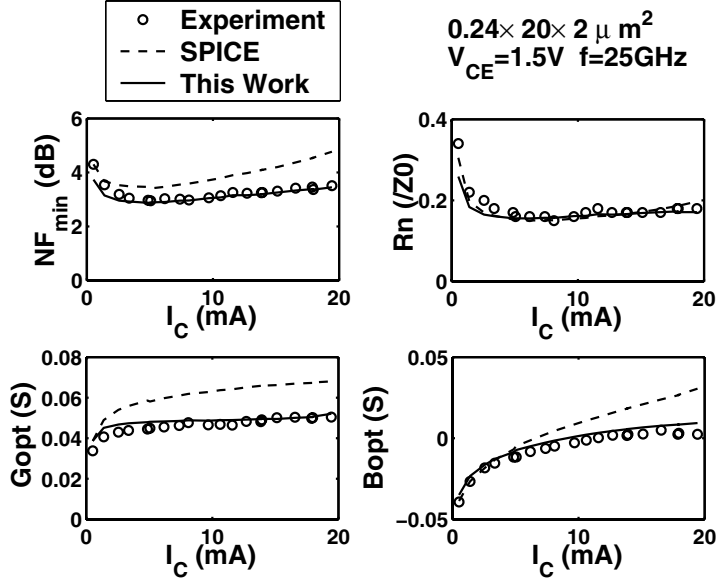


Figure 4.13: Noise parameters versus collector current for the measured noise data. $f=25$ GHz. $A_E=0.24 \times 20 \times 2\mu\text{m}^2$.

of the intrinsic noise model parameters. $I_C=17.9$ mA, $f=25$ GHz. $A_E=0.24 \times 20 \times 2\mu\text{m}^2$. We list only the noise model parameters that have a large impact on the noise parameters at higher biasing currents and higher frequencies. B_{bb^*} , $B_{cb^*}^i$ and B_{cc^*} mainly affect low bias noise parameters and thus are not listed. The sensitivity analysis shows that:

- The noise parameters are sensitive to model parameters for $\Im(S_{icib^*})$, including $K_{cb^*}^i$ and $\alpha_{cb^*}^i$.
- S_{ic} (through K_{cc^*}) is as important as S_{ib} (through K_{bb^*}) at high frequencies.
- The noise parameters are not sensitive to $\Re(S_{icib^*})$ (through $K_{cb^*}^{br}$ and $K_{cb^*}^{kr}$). This explains why $\Re(S_{icib^*})$ can be set to zero and produce good noise parameter fitting.

Table 4.3: Parameter sensitivity at $I_C=17.9\text{mA}$, $f=25\text{GHz}$. $A_E=0.24 \times 20 \times 2\mu\text{m}^2$. Percentage variance of noise parameters responding to 5% variance of the noise model parameters.

	NF_{min}	R_n	G_{opt}	B_{opt}
K_{cb}^i	29.10%	10.17%	22.5%	233.3%
α_{cb}^i	22.58%	8.6%	21.25%	175.0%
K_{bb}^*	7.94%	4.94%	4.14%	78.82%
K_{cc}^*	7.94%	3.48%	5.79%	50%
α_{bb}	7.62%	4.94%	4.72%	78.57%
α_{cc}	3.29%	0.3%	2.92%	23.5%
K_{cb}^{kr}	0.14%	0.33%	0.61%	5.25%
K_{cb}^{br}	0.035%	0.12%	2.63%	1.3%

4.3 Emitter geometry scaling

Optimal transistor sizing and biasing are important for high performance RF low-noise amplifier design using SiGe HBTs. This calls for accurate understanding and modeling of the emitter geometry scaling behavior of RF noise sources, including the correlated intrinsic base and collector current noises, their correlation, the thermal-like noise of intrinsic base resistance and the well know $4kTR$ thermal noises due to extrinsic terminal resistances. In SiGe HBTs, the crowding effect on noise voltage of r_{bi} is negligible because of the high base doping, therefore the r_{bi} noise can be approximated with $4kTr_{bi}$.

The study of scaling issue is based on experimental data of SiGe HBTs with different emitter geometries, indicates emitter length (LE), emitter width (WE) and emitter finger number (NE) scaling respectively. We first extract the small signal equivalent circuit parameters from measured s-parameters, and then extract the intrinsic base and collector current noises using standard noise de-embedding method [2] from measured noise parameters. With the extraction results, different scaling effects on intrinsic noise and resistance noise are discussed. The geometry scalability of our semi-empirical model is examined.

4.3.1 Intrinsic noise scaling

Ideally for transistors of the same vertical profile, if they are biased to have the same collector current density J_C , their dc currents, ac currents and Y-parameters are proportional to emitter area $A_E (= W_E \times L_E \times N_E)$, where W_E , L_E and N_E are the emitter width, length and number of fingers respectively. Using a given emitter area A_{E0} as a reference, I_B , I_C , g_m and $\Re(Y_{21})$ for other emitter geometries can be calculated using corresponding emitter area scaling factor $M (= A_E/A_{E0})$. Similarly, the PSDs of the intrinsic base and collector current noise and their correlations scale linearly with A_E in this ideal case. Here the $0.24 \times 20 \times 2\mu m^2$ device is used as a reference. Our noise extraction results for different emitter geometries indeed show that the intrinsic noise PSDs obey such ideal scaling rule. In Fig. 4.14, the extracted intrinsic noises for each device are divided by its M factor and plotted versus I_C/M at $f=15$ GHz. For S_{ib} , S_{ic} and $\Im(S_{icb^*})$, the normalized data of the four devices overlap well. The trend is not obvious for $\Re(S_{icb^*})$, primarily due to extraction difficulties. $\Re(S_{icb^*})$ is one order of magnitude lower than $\Im(S_{icb^*})$, and has much weaker effect on noise parameters. Therefore $\Re(S_{icb^*})$ is easily affected by measurement noise. Furthermore we found that all α terms in the model are approximately emitter geometry independent. This leads to the following scaling rule for the K and B terms in the proposed noise model as

$$K_{bb^*} = K_{bb^*0} M^{1-\alpha_{bb^*}}, B_{bb^*} = B_{bb^*0} M, \quad (4.30)$$

$$K_{cc^*} = K_{cc^*0} M^{-\alpha_{cc^*}}, B_{cc^*} = B_{cc^*0}, \quad (4.31)$$

$$K_{cb^*}^{br} = K_{cb^*0}^{br}, \quad K_{cb^*}^{kr} = K_{cb^*0}^{kr} / M, \quad (4.32)$$

$$K_{cb^*}^i = K_{cb^*0}^i M^{1-\alpha_{cb^*}^i}, B_{cb^*}^i = B_{cb^*0}^i M. \quad (4.33)$$

where the subscript 0 denotes the reference transistor. Since all of the noise current PSDs scale linearly with the emitter area, the normalized correlation c does not change, $|c| \leq 1$ is kept satisfied.

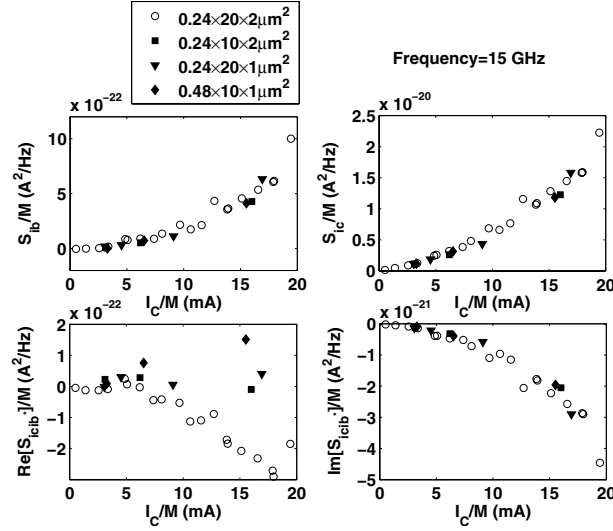


Figure 4.14: Extracted intrinsic noise divided by M vs I_c/M at $f=15$ GHz, where M is the emitter geometry scaling factor.

We now verify the geometry scaling ability of the new model with measured noise data of different emitter geometries. The $0.24 \times 20 \times 2 \mu\text{m}^2$ device is used as a reference. We use $0.24 \times 10 \times 2 \mu\text{m}^2$ for emitter length scaling, $0.24 \times 20 \times 1 \mu\text{m}^2$ for number of emitter finger scaling and $0.48 \times 10 \times 1 \mu\text{m}^2$ for emitter width scaling. The model parameters for all devices satisfy the scaling rule given by (4.30)—(4.33). Note that the emitter area scaling factor M is 2 for all three scaled devices. The noise figures are shown in Figs. 5.18, 4.16, 4.17 for $A_E = 0.24 \times 10 \times 2 \mu\text{m}^2$, $A_E = 0.24 \times 20 \times 1 \mu\text{m}^2$ and $A_E = 0.48 \times 10 \times 1 \mu\text{m}^2$ respectively. For each emitter geometry, a low bias and a high bias point are shown. Excellent agreement between modeling and measurement has been achieved for all of the four noise parameters and for all of the emitter geometries. Note that the collector voltage V_{CE} of different size devices are different. The V_{CE} effect has been taken into account by the small signal parameters.

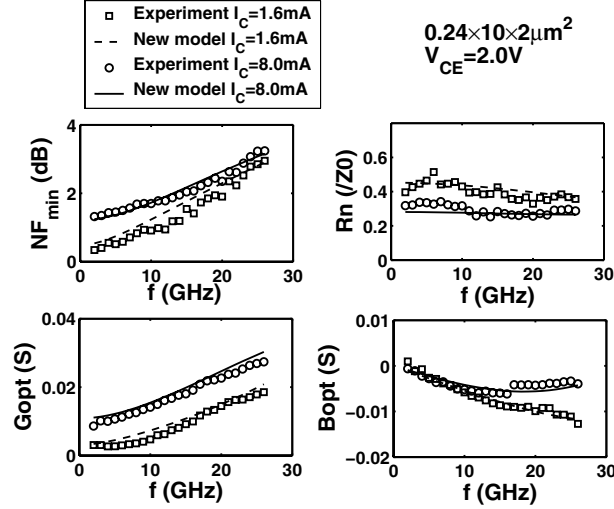


Figure 4.15: Noise parameters versus frequency for $0.24 \times 10 \times 2 \mu\text{m}^2$ SiGe HBT at $I_c=1.6$ mA and 8.0 mA. $V_{CE}=2.0$ V.

Table 4.4: Extracted r_{bx} , r_{bi} for 50 GHz SiGe HBTs with different emitter geometries

Emitter geometry (μm^2)	M	r_{bx} (Ω)	r_{bi} at peak f_T (Ω)	$r_{bx} \times LE \times NE$ ($\Omega\mu\text{m}$)	$r_{bi} \times LE \times NE$ ($\Omega\mu\text{m}$)
$0.24 \times 20 \times 2$	Ref.	2.70	2.68	108	107.2
$0.24 \times 10 \times 2$	1/2	3.70	5.75	74	115
$0.24 \times 20 \times 1$	1/2	11.5	10.5	230	210
$0.48 \times 10 \times 1$	1/2	13.0	21.1	-	-

4.3.2 Extrinsic noise scaling

Now we consider the geometry scaling of noises due to parasitic resistances. For SiGe HBT noise, r_{cx} is less important and r_e is relatively small, hence only r_{bx} and r_{bi} are considered here. Since the intrinsic noise has shown to scale with AE ideally, if both r_{bx} and r_{bi} inversely scale with AE, the four normalized noise parameters, i.e., NF_{min} , $R_n \times M$, G_{opt}/M and B_{opt}/M , will nearly be geometry independent [1]. This will make optimal transistor sizing easier in LNA design.

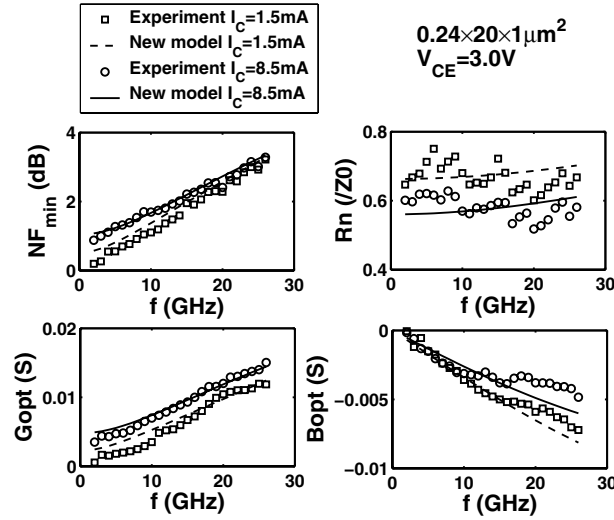


Figure 4.16: Noise parameters versus frequency for $0.24 \times 20 \times 1 \mu\text{m}^2$ SiGe HBT at $I_c=1.6$ mA and 8.0 mA. $V_{CE}=3.0$ V.

Table 4.4 shows the extracted r_{bx} , r_{bi} for SiGe HBTs with different geometries. For base resistance, as WE scaling is quite different with LE and NE scaling, we do not evaluate the normalized resistance values for WE case. For LE scaling, we compare the $0.24 \times 10 \times 2 \mu\text{m}^2$ HBT with the $0.24 \times 20 \times 2 \mu\text{m}^2$ reference device. Their normalized base resistances are close to each other as shown in Table 4.4 suggesting a near ideal LE scaling. Consequently, the four normalized noise parameters overlap with each other as shown in Fig. 4.18. Next we consider NE scaling by comparing the $0.24 \times 20 \times 1 \mu\text{m}^2$ HBT with the $0.24 \times 20 \times 2 \mu\text{m}^2$ reference. Their normalized r_b values have a large difference due to the path resistances connected to base, leading to the discrepancy of normalized noise parameters. NF_{min} is reduced using multiple emitter fingers as shown in Fig. 4.18. For the three scaling strategies, only emitter length scaling is near ideal and should be primarily considered during noise matching.

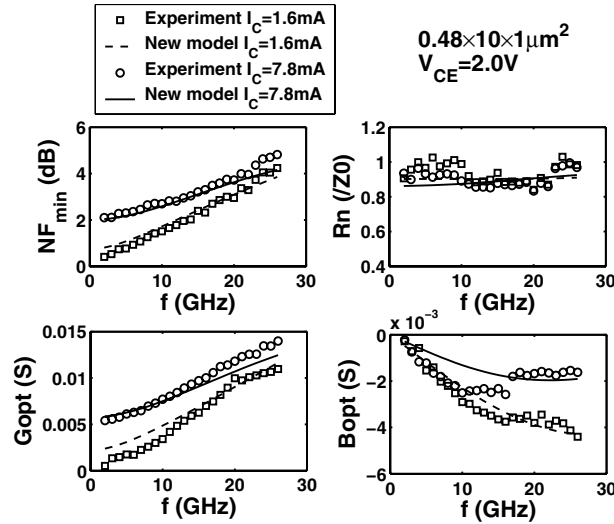


Figure 4.17: Noise parameters versus frequency for $0.48 \times 10 \times 1 \mu\text{m}^2$ SiGe HBT at $I_C=1.6$ mA and 7.8 mA. $V_{CE}=2.0$ V.

4.3.3 Comparison of intrinsic noise with resistance noise

To compare the relative importance of noise sources in SiGe HBTs, we calculate three types of NF_{min} versus I_C as shown in Fig. 4.19. The solid line is calculated including both intrinsic noise and resistance noise, the dash line is calculated including only intrinsic noise and the dash dot line is calculated including only resistance noise. Note these NF_{min} do not have simple relation. For all the devices examined, the intrinsic noise contributes more noise. The bias dependence of NF_{min} mainly comes from the bias dependence of intrinsic noise. The resistance noise adds about 1dB to NF_{min} for all the four devices and is important. Once their values are well modeled, we can model the noise parameters accurately.

4.4 Implementation in CAD tools

The semi-empirical model can be easily applied in present CAD tools. Here we demonstrate its implementation in VBIC model using Analog-A language for Advanced Design System (ADS), Agilent Technologies.

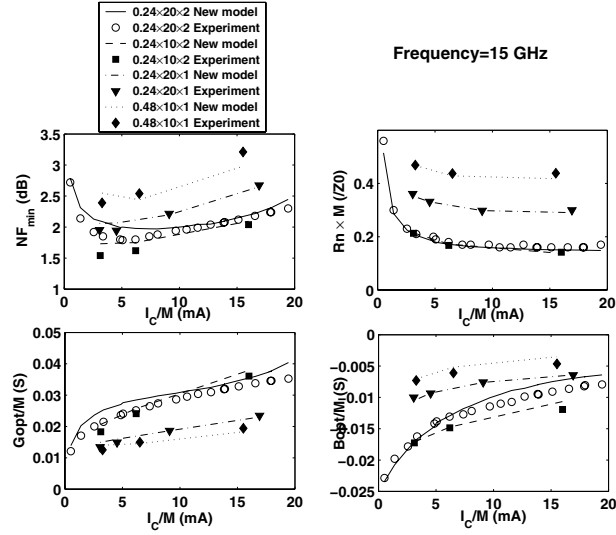


Figure 4.18: Normalized noise parameters versus I_c/M at $f=15$ GHz.

Fig. 4.20 illustrates the technique to introduce correlated intrinsic transistor noise sources that give PSDs in (4.26)–(4.29) for VBIC model. We add two isolated nodes v_a and v_b , each of them is connected to ground through a 1 Ohm noiseless conductance. Unity white noise currents i_a and i_b are injected into node v_a and v_b respectively, producing noise voltage v_a and v_b . We have

$$S_{v_a} = S_{i_a} = 1, \quad S_{v_b} = S_{i_b} = 1. \quad (4.34)$$

We add $2qI_b$ shot noise current and $g_1 \text{ddt}(v_a)$ noise current between base node bi and emitter node ei . Note that the time derivative operator ddt in Analog-A generates $j\omega$ factor in frequency domain, leading to the frequency dependence of noise source. We then add two noise currents $g_2 v_a$

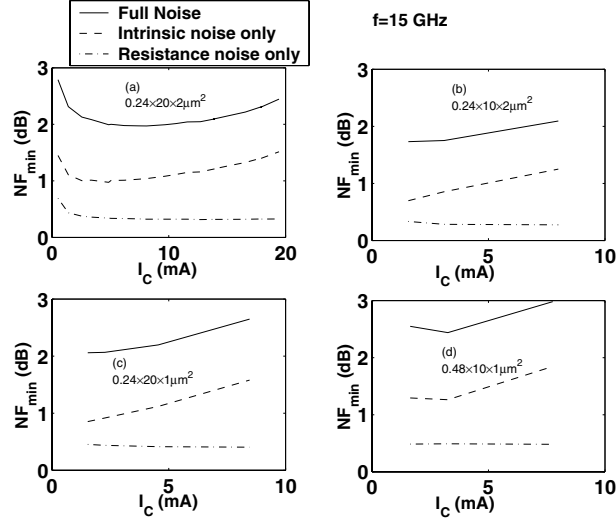


Figure 4.19: NF_{min} versus I_c , determined by intrinsic noise only, resistance noise only and both of intrinsic and resistance noise for different geometry SiGe HBTs: (a) $0.24 \times 20 \times 2 \mu m^2$; (b) $0.24 \times 10 \times 2 \mu m^2$; (c) $0.24 \times 20 \times 1 \mu m^2$; (d) $0.48 \times 10 \times 1 \mu m^2$.

and $g_3 v_a$ between collector node ci and emitter node ei . We have

$$\begin{aligned}
 S_{ib} &= 2qI_b + S_{v_a} g_1^2 \omega^2 = 2qI_b + \omega^2 g_1^2, \\
 S_{ic} &= S_{v_a} g_2^2 + S_{v_b} g_3^2 = g_2^2 + g_3^2, \\
 S_{icib^*} &= S_{v_a} (-j\omega g_2 g_1) = -j\omega g_2 g_1.
 \end{aligned} \tag{4.35}$$

The correlation between base and collector current noises thus is obtained by the controlled noise currents $g_1 ddt(v_a)$ and $g_2 v_a$. Now we need to find the expressions of g_1 , g_2 and g_3 . For simplicity, $\Re(S_{icib^*})$ is set to zero. The frequency dependence of S_{ic} are neglected. $\Re(Y_{21})$ and g_m are replaced with qI_C/kT since g_m is not referable in Analog-A of present versions. Comparing (4.35) with

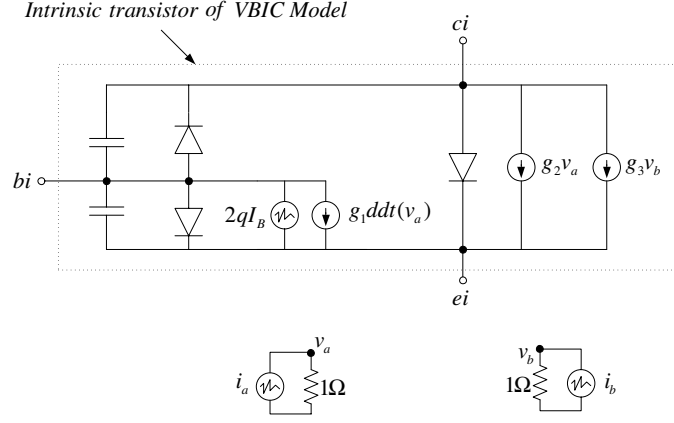


Figure 4.20: Technique of insertion of correlated noise sources into the intrinsic transistor of VBIC model.

(4.26)–(4.29), we have

$$g_1 = \sqrt{K_{bb^*} \alpha_{bb^*} + B_{bb^*}}, \quad (4.36)$$

$$g_2 = \frac{K_{cb^*}^i \alpha_{cb^*}^i}{\sqrt{K_{bb^*} \alpha_{bb^*} + B_{bb^*}}}, \quad (4.37)$$

$$g_3 = \sqrt{(K_{cc^*} \alpha_{cc^*} + B_{cc^*}) \mathcal{R}(Y_{21}) - \frac{(K_{cb^*}^i \alpha_{cb^*}^i)^2}{K_{bb^*} \alpha_{bb^*} + B_{bb^*}}}. \quad (4.38)$$

A similar method of introducing correlated i_b and i_c noise is given in [70], where noise correlation $i_b i_c^*$ is introduced while i_b and i_c are still $2qI_b$ and $2qI_c$ white shot noise. This clearly is non-physical. As discussed in Chapter 2, $2qI_b$ is mainly contributed by emitter hole noise for modern transistors. It is the base electron noise that produces significant correlation between i_b and i_c . The electron noise will inevitably produce frequency dependent excess noise current to i_b . It is this excess noise current of i_b correlated with i_c . In our method, the electron noise is described by g_1 , g_2 and g_3 .

The Analog-A code for implementation of (4.36)–(4.38) in VBIC model is given in Appendix G. Figs. 4.21, 4.22 show the noise parameters versus frequency simulated by ADS using semi-empirical noise model and SPICE noise model respectively at $I_C=15.1$ mA. Clearly the new model improves noise modeling and gives the same results calculated by MATLAB in the previous section.

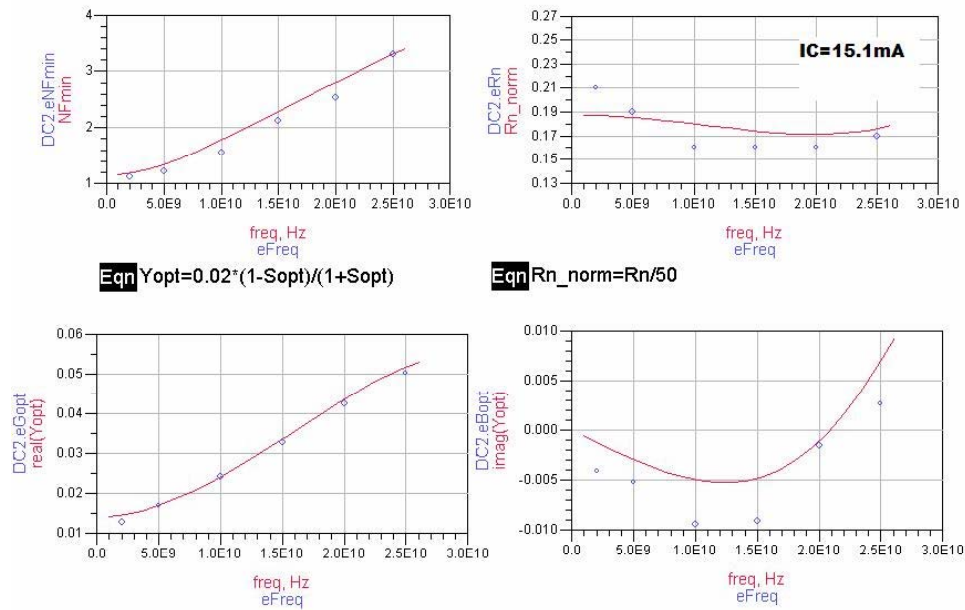


Figure 4.21: Noise parameters versus frequency simulated by ADS using semi-empirical noise model at $I_C=15.1$ mA.

4.5 Summary

We have presented the noise de-embedding method for SiGe HBTs using a QS input equivalent circuit. The intrinsic transistor noises are then extracted through noise de-embedding method, and modeled as functions of bias and frequency based on inspection of extraction results. The modeling methodology is demonstrated using noise parameters measured from 2 to 25 GHz on SiGe HBTs featuring a 50 GHz peak f_T . The imaginary part of the correlation $\Im(S_{icib^*})$ is found

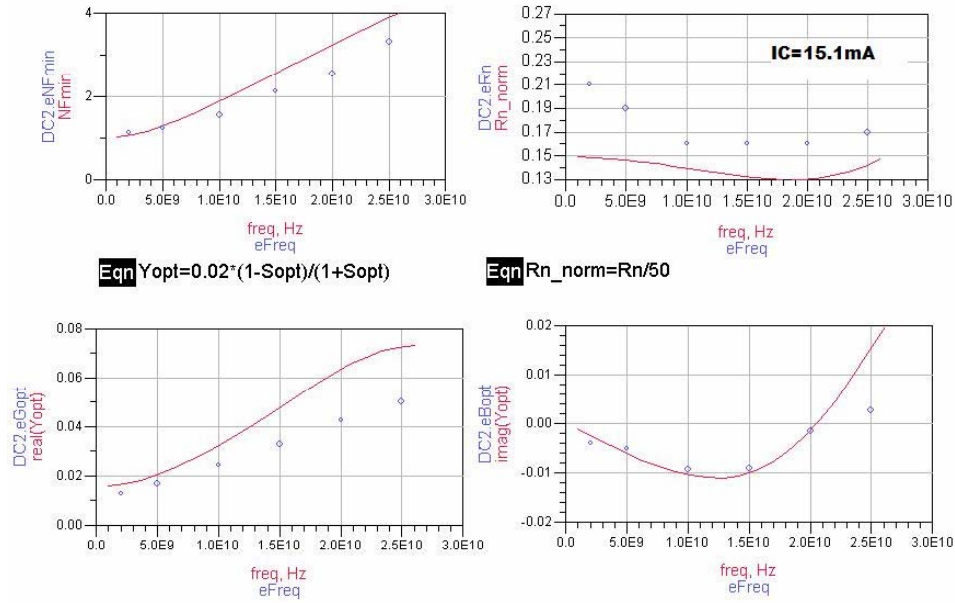


Figure 4.22: Noise parameters versus frequency simulated by ADS using SPICE noise model at $I_C=15.1\text{ mA}$.

to be proportional to ω . S_{ib} and the real part of the correlation $\Re(S_{icib^*})$ are found to be proportional to ω^2 . S_{ic} is found to be proportional to $\Re(Y_{21})$. $\Im(S_{icib^*})$ is found to be much greater than $\Re(S_{icib^*})$, and has a much larger impact on noise parameters. The bias dependence of all of the noise terms can all be modeled using g_m . Excellent fitting of both Y-parameters and noise parameters has been achieved. The new semi-empirical model is capable of geometry scaling and can be implemented in present CAD tools.

CHAPTER 5

IMPROVED PHYSICAL NOISE MODEL

With the technology advances, transistors are scaled, and have narrower base width and emitter width. Some effects related to BC and BE junctions are non-negligible any longer. This chapter improves compact RF noise modeling for SiGe HBTs based on NQS equivalent circuit by taking in account some of these effects. The impact of CB SCR on electron RF noise is examined to be important for scaled SiGe HBTs. The van Vliet model is then improved to account for the CB SCR effect. The impact of fringe BE junction on base hole noise is further investigated. Due to fringe effect, the base hole noise should be modeled with correlated noise voltage source and noise current source in hybrid representation. The base noise resistance is found to be different from AC intrinsic base resistance, and thus is modeled by an extra parameter. With four bias-independent model parameters in total, the combination of electron and hole noise model provides excellent noise parameter fittings for frequencies up to 26 GHz and all biases before f_T roll off for three generations of SiGe HBTs. The new model is also capable of emitter geometry scaling.

5.1 CB SCR effect on electron noise

As reviewed in Chapter 2, the van Vliet model solves the microscopic noise transport equation for base minority carrier (electrons for NPN considered here). Van Vliet's derivation of base and collector current noise PSDs assumed adiabatic boundary condition i.e. $\tilde{n}=0$ or zero electron density fluctuation at both ends of the base, and did not consider electron transport in the CB SCR. For scaled bipolar transistors, e.g. SiGe HBTs of 200 GHz peak f_T , CB SCR electron transport

becomes more significant than base electron transport, calling for an investigation of its impact on transistor noise.

The extremely useful result of van Vliet's derivation is that the base and collector current noise and their correlation can be related to the Y-parameters due to intrinsic base electron transport, Y^B . As shown in (2.69), the van Vliet model can be extended to include emitter hole noise by replacing Y^B with the Y-parameters of base and emitter region Y^{EB} . In the literature, the van Vliet model is often applied using Y-parameters of the whole intrinsic transistor, e.g. in [2] and [47], as opposed to Y^{EB} , for which the model was derived. Physically speaking, both the Y-parameters and the noise parameters are modified by electron transport through the CB SCR, it is not clear at all what the relation between Y-parameters and transistor noise should be when the CB SCR is accounted for.

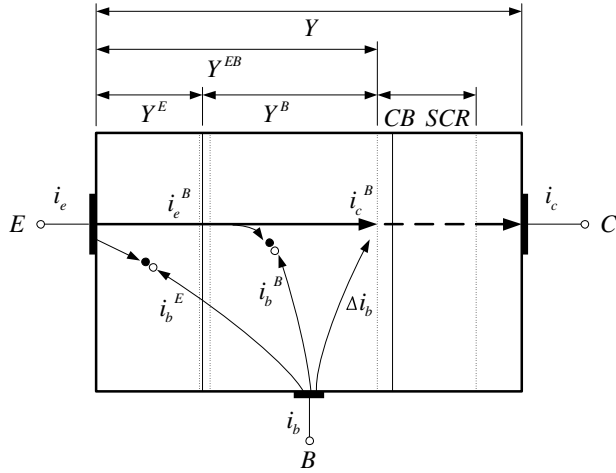


Figure 5.1: Illustration of AC or noise current flows in ideal 1-D intrinsic SiGe HBT.

Here we investigate the impact of CB SCR on transistor noise and derive an improved noise model including such impact. The CB SCR affects electron transport (and hence noise transport) in two ways. First, a velocity saturation boundary condition should be applied at the end of neutral base. Its effect on DC currents and base transit time, and noise has been investigated in Chapter

2. With a strong base built-in field, typically the case of graded SiGe HBTs, the van Vliet model can still correctly describe base electron noise. Therefore, we can continue to use van Vliet model for the relationship between noise and Y-parameters of the intrinsic base for graded SiGe HBTs. Secondly, electron transport through the CB SCR modifies both the Y-parameters and the noise parameters. The noise generated within CB SCR is neglected. The main CB SCR effect accounted is τ_c delay, which was briefly discussed in [5]. We derived a new set of relationship between noise currents and Y-parameters in presence of CB SCR delay based on van Vliet model. Here we note that τ_c effect was also included in [71]. However, the base region noise in [71] is derived from 1-D transmission line analogy without including base built-in field, and needs extra parameters (electron diffusion coefficient D_n , life time τ_n and base width X_B). Therefore it is much less general than our van Vliet model based result, which is based on Y-parameters that can be measured.

5.1.1 Model equation derivation

We denote the AC electron current injected into CB SCR as i_c^B and the AC collector current as i_c . The electrons inside the CB SCR induce base hole accumulation at the SCR side of the base region and electron depletion at the SCR side of the collector region. The first part adds an extra base hole current Δi_b , which is $i_c^B - i_c$, to original base current i_b^B . Note that i_c and i_b take positive signs when they flow into the electrodes. Physics analysis [72] shows that i_c and i_c^B can be related by

$$\lambda(\omega) \equiv \frac{i_c}{i_c^B} = \frac{1 - e^{-2j\omega\tau_c}}{2j\omega\tau_c},$$

where τ_c is the collector transit time. The total AC/noise base and collector currents can be derived as

$$i_b = (i_b^E + i_b^B) + (1 - \lambda)i_c^B, \quad i_c = \lambda i_c^B. \quad (5.1)$$

With (5.1) and by neglecting Y_{12}^{EB} and Y_{22}^{EB} , we obtain the Y-parameters of the whole intrinsic transistor including CB SCR as

$$Y_{11} = Y_{11}^{EB} + (1 - \lambda)Y_{21}^{EB}, \quad Y_{21} = \lambda Y_{21}^{EB}. \quad (5.2)$$

The noise PSDs including CB SCR transport are derived from (5.1) as

$$\begin{aligned} S_{i_b} &\equiv \langle i_b i_b^* \rangle = S_{i_b}^{EB} + 2\Re[(1 - \lambda)S_{i_{cib}^*}^{EB}] + |1 - \lambda|^2 S_{i_c}^{EB}, \\ S_{i_c} &\equiv \langle i_c i_c^* \rangle = |\lambda|^2 S_{i_c}^{EB}, \\ S_{i_{cib}^*} &\equiv \langle i_c i_b^* \rangle = \lambda S_{i_{cib}^*}^{EB} + \lambda(1 - \lambda^*)S_{i_c}^{EB}. \end{aligned} \quad (5.3)$$

Here S^{EB} is given in (2.69). Fig. 5.2 shows the effect of τ_c on noise, $\tau_c=0$ for the dash lines and $\tau_c=0.75\tau_{tr}$ for the solid lines. Emitter hole noise is not included. Clearly the base current noise is significantly *enlarged* due to CB SCR electron transport, particularly with increasing frequency. It is a direct result of increase of AC base current caused by CB SCR effect.

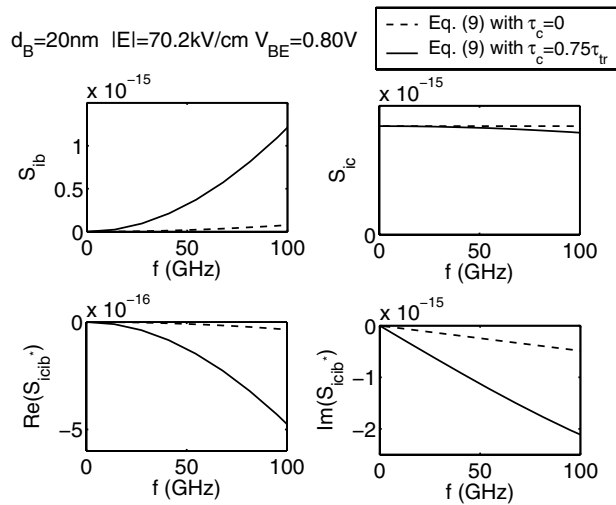


Figure 5.2: Comparison of the intrinsic noise with $\tau_c=0$ and $\tau_c=0.75\tau_{tr}$. For $\tau_c=0.75\tau_{tr}$, $f_T=174$ GHz. Emitter hole noise is not included.

For various reasons discussed above, it is highly desirable to express the noise PSDs in (5.3) in terms of the Y-parameters for the whole intrinsic transistor Y . A set of such expressions are derived below

$$\begin{aligned}
S_{ib} &= 4kT\Re(Y_{11}^{EB}) - 2qI_b + 4kT\Re[(1 - \lambda)Y_{21}^{EB}] - 4kT\Re(1 - \lambda)g_m + |1 - \lambda|^2 S_{ic}^{EB} \\
&= 4kT\Re(Y_{11}) - 2qI_b - 4kT\Re(1 - \lambda)g_m + |1 - \lambda|^2 2qI_c \\
&= \{4kT\Re(Y_{11}) - 2qI_b\} + 2qI_c|1 - \lambda|^2 - 4kTg_m\Re(1 - \lambda), \\
S_{ic} &= \{2qI_c\}|\lambda|^2, \\
S_{icib^*} &= \lambda 2kTY_{21}^{EB} - \lambda 2kTg_m + \lambda(1 - \lambda^*)S_{ic}^{EB} \\
&= \{2kTY_{21} - \lambda 2kTg_m\} + \lambda(1 - \lambda^*)2qI_c \\
&= \{2kT(Y_{21} - g_m)\} + 2qI_c(\lambda - |\lambda|^2) + 2kTg_m(1 - \lambda). \tag{5.4}
\end{aligned}$$

We illustrate the S_{ib} derivation as an example. The first step is obtained directly from (5.3) and (2.69). The second step is obtained using (5.2). Note that the terms enclosed by $\{ \}$ in (5.4) are the noise expressed by van Vliet model using the Y-parameters of whole transistor, a brutal force application of van Vliet model (using Y despite that it needs Y^{EB} – often used without justification). The additional terms in our new model, (5.4), represent the error introduced by using the van Vliet model with the overall transistor Y-parameters.

Fig. 5.3 compares the improved model, the brutal use of van Vliet model and the exact result, that is, Langevin equation solution used with (5.3). The improved model works very well, and gives results nearly identical to the exact result. S_{ib} and $|\Re(S_{icib^*})|$ are overestimated by the brutal use of van Vliet model, while $|\Im(S_{icib^*})|$ is correctly modeled for the analytical result where $g_m = I_c/V_T$. For practical SiGe HBTs, g_m is typically smaller than I_c/V_T at high current levels [1]. Consequently, the brutal use of van Vliet model cannot correctly model $|\Im(S_{icib^*})|$ at high I_c . The inconsistent modeling of S_{ib} and $|\Im(S_{icib^*})|$ results in an overestimation of NF_{min} for the brutal

Table 5.1: Extracted delay time from DESSIS simulation data

Peak f_T (GHz)	Device (μm^2)	τ_c (ps)	τ_{tr} (ps)	τ_c/τ_{tr}
65	0.5×1	0.57	2.1	27%
85	0.2×1	0.55	1.5	37%
183	0.12×1	0.58	0.86	67%

use of van Vliet model. The magnitude of derivation depends on the ratio τ_c/τ_{tr} , which increases with scaling. Table 5.1 shows the extracted τ_c/τ_{tr} ratio from DESSIS simulated three generations of SiGe HBTs using the method of [73]. The ratio increases with device scaling, indicating that the BC SCR has more significant impact on higher f_T devices. Even though the differences look small on the plots shown, the resulting differences in noise parameters of the intrinsic transistor (NF_{min} , R_n , and Y_{opt}) are significant, making them important to model. For transistors in which base resistance is large, the final impact on overall transistor noise parameters is smaller, simply because of the less importance of intrinsic transistor noise.

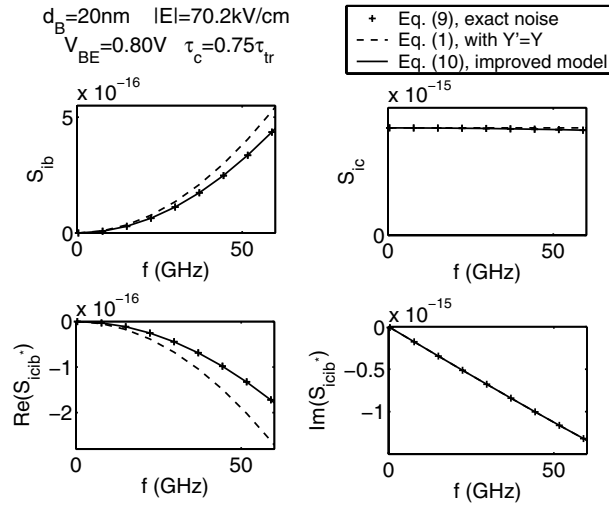


Figure 5.3: Comparison between the brutal used van Vliet model and the improved model under $\tau_c=0.75\tau_{tr}$. $f_T=174$ GHz.

5.1.2 Verification and discussion

To verify our derivations, we examine the new model using hydrodynamic DESSIS noise simulation. The device has 184 GHz peak f_T with effective $d_B=20\text{nm}$. At $V_{BE} = 0.79\text{V}$, $\tau_c=0.75(\tau_b+\tau_c)$, $f_T=155\text{ GHz}$. Fig. 5.4 compares the improved model with the extracted τ_c , the brutal use of van Vliet model and the extracted intrinsic base electron noise. The new model improves S_{ib} and $\Re(S_{icib*})$ modeling. The DESSIS simulated $S_{ic} < 2qI_C$ is a direct result of hydrodynamic simulation.

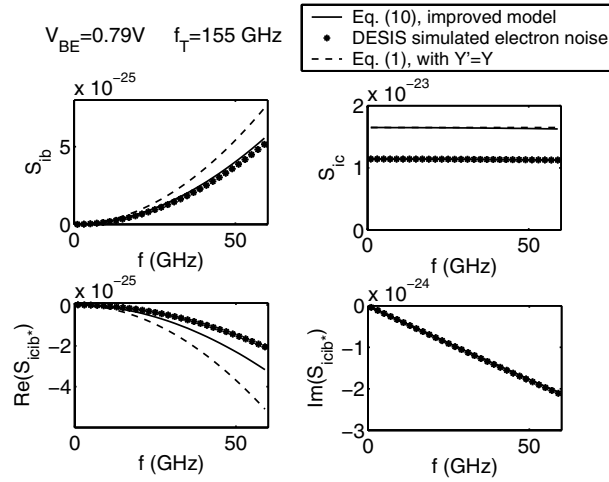


Figure 5.4: Comparison between van Vliet model, new model and the extracted intrinsic noise from DESSIS simulation results. $\tau_c=0.75(\tau_b+\tau_c)$ is used in the new model. Effective $d_B=20\text{nm}$, $\eta=5.4$, $|E|=70.2\text{ kV/cm}$.

We approximate (5.4) up to the second order of ω . $g_{be} = I_b/V_T$ are assumed. The frequency dependence of S_{ib} caused by emitter hole noise is negligible compared to that of base electron

noise (see Fig. 2.14). We have

$$\begin{aligned}
S_{ib} &\approx 2qI_b + \omega^2 \left[4kTg_m \left(\tau_{tr}\tau_{in} - \frac{2}{3}\tau_c^2 \right) + 2qI_c\tau_c^2 \right], \\
S_{ic} &\approx 2qI_c - \omega^2(2/3qI_c\tau_c^2), \\
S_{icib^*} &\approx -j\omega [2kTg_m(\tau_{in} + \tau_{out} - \tau_c) + 2qI_c\tau_c] - \omega^2 \left[2kTg_m \left(\tau_{in}^2 + \tau_{in}\tau_{out} + \frac{1}{2}\tau_{out}^2 - \frac{2}{3}\tau_c^2 \right) + \frac{2}{3}qI_c\tau_c^2 \right].
\end{aligned} \tag{5.5}$$

Clearly for general case where $g_m \neq I_c/V_T$, (5.5) cannot be simplified using three or four lumped model parameters.

Now we consider an extreme case, i.e. $\tau_c \gg \tau_b$ or $\tau_c \approx \tau_{tr}$. This eventually becomes the physical scenario described by the transport noise model [44] [43]. Under such condition, $\tau_{in} \rightarrow 2/3\tau_{tr}$ and $\tau_{out} \rightarrow 1/3\tau_{tr}$ as discussed in Chapter 3. We then have

$$\begin{aligned}
S_{ib} &\approx 2qI_b + \omega^2(2qI_c\tau_c^2), \\
S_{ic} &\approx 2qI_c - \omega^2(2/3qI_c\tau_c^2), \\
S_{icib^*} &\approx -j\omega(2qI_c\tau_c) - \omega^2 \left(\frac{1}{9}kTg_m + \frac{2}{3}qI_c \right) \tau_c^2.
\end{aligned} \tag{5.6}$$

Comparing with the Taylor expression of transport model equations in Chapter 4, we found that

$$\begin{aligned}
S_{ib} &\approx S_{ib}^{tran}, \\
S_{ic} &\approx S_{ic}^{tran} + 2/3\Re(S_{icib^*}^{tran}), \\
S_{icib^*} &\approx S_{icib^*}^{tran} - 4/9\Re(S_{icib^*}^{tran}).
\end{aligned} \tag{5.7}$$

This shows that under $\tau_c \gg \tau_b$ condition, the transport noise model does not well model the intrinsic noise. However, it is a good approximation as S_{ib} and $\Im(S_{icib^*})$ have been correctly

modeled. The improved model thus provides a means of “bridging” the van Vliet model and the transport noise model.

5.2 Fringe BE junction effect on base hole noise

Base hole noise is another major noise source for SiGe HBTs. Traditionally this noise is modeled by the thermal noise of r_{bx} and r_{bi} , the small signal base resistance for the extrinsic and intrinsic region respectively. r_{bx} is the resistance of a true resistor whose noise can be well modeled with $4kTr_{bx}$. However, r_{bi} is a lumped resistance. There are two kinds of r_{bi} , depending on whether QS equivalent circuit or NQS equivalent circuit is used. As discussed in Chapter 2 and Chapter 3, $r_{bi,nqs}$ is more physical and also smaller than $r_{bi,qs}$. We found problems of using $4kTr_{bi}$ for noise modeling based on either QS or NQS lumped equivalent circuit. Firstly, noise resistance R_n cannot be well modeled, which is sensitive to base hole noise. One has to use an empirical S_{ic} based on noise extraction, which is unphysically larger than $2qI_c$ for 50 GHz SiGe HBTs [2]. Another problem is that the absolute value of the imaginary part of noise parameter Y_{opt} , i.e. B_{opt} , is overestimated by van Vliet model based on NQS equivalent circuit. The deviation cannot be eliminated by choosing appropriate r_{bi} . This work aims to solve these two problems by modeling the distributive effect of base hole noise.

The distributive effect is a significant feature of intrinsic base hole noise [48]. The best way to examine this effect is through microscopic noise simulation. There exist two kinds of distributive effect, the fringe effect associated with the edge transistor and the crowding effect associated with the intrinsic transistor. To account for these effects, we divide the BE/BC junction into four segments A_{1-4} , leading to five equivalent base resistances of three types as shown in Fig. 5.5. Further analysis shows that at least four segments (five resistors) are needed. Type I resistances are for the edge transistors. Type III resistances are for the main intrinsic transistor. Type II resistances are a combination of resistances from the main and edge transistors. Because of the narrow emitter width

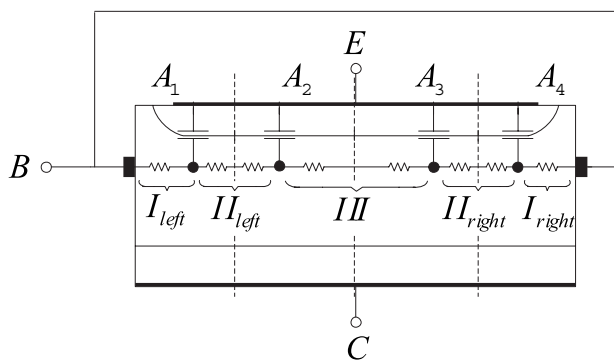


Figure 5.5: Illustration of base distribution effect by dividing the base resistances into five segments of three types. Double base contact is used.

and high base doping, DC crowding effect is negligible in practice. Hence the traditional $4kTr_{bi}$ description is theoretically true only for the main intrinsic transistor *without* the fringe region [41]. In lumped equivalent circuit based modeling, the fringe region or edge transistor is not explicitly separated from the main intrinsic region [2, 51, 52]. However it is unknown how the fringe effect affects base hole noise and how important the effect is.

We will show that the base hole noise should be modeled by a noise voltage source at the input and a correlated noise current source at the output due to the fringe effect. The f_T is no longer assumed to be uniform across the whole BE junction as opposite to [41]. The fringe transistor has lower f_T because of wider base at the edge of emitter and smaller V_{BE} . It is the correlation of the two noise sources that cause the B_{opt} problem described above. The base noise resistance needed to fit noise data from both microscopic noise simulation and measurements is found to be not the same as r_{bi} , which cannot be explained by fringe effect. Such observation based on simulation was also reported in [46]. We hence use an extra parameter R_{bn} as base noise resistance to improve R_n fitting. DESSIS device simulation is used as guidance, as base hole and electron noises can be separated in simulation. Experimental data are used to verify the new model.

5.2.1 Physical considerations

The five resistance model has captured both the fringe effect and crowding effect of base hole noise in a lumped fashion. Fig. 5.6 shows the small signal equivalent circuit that corresponds to Fig. 5.5. The five resistances correspond to those five segments. The four capacitors and

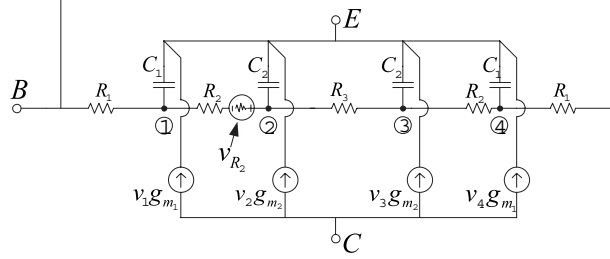


Figure 5.6: Small signal equivalent circuit of five segments model. Only the noise voltage source of left R_2 is shown. g_{be} is neglected. Four nodes are labeled.

transconductances correspond to segment A_{1-4} . Note that $g_{m2} \gg g_{m1}$, $C_2 \gg C_1$. g_{be} is neglected in Fig. 5.6 which is only used for base hole noise derivation. The g_{be} in the small signal equivalent circuit of SiGe HBT is not neglected. All the small signal components are connected through four inner nodes. The resulting equivalent circuit is symmetric.

Although the DC base-emitter bias is the same for A_{1-4} segments, the local f_T varies along the emitter junction. A_2 and A_3 have the same f_T . A_1 and A_4 , however, have lower f_T because of wider base of the edge transistor, meaning that $g_{m1}/C_1 < g_{m2}/C_2$. The smaller local f_T does not affect the transistor f_T much because of the small area of A_1 and A_4 compared to A_2 and A_3 . However we will show that just because of the non-uniformity of f_T , base hole will produce noise current at the collector. This result cannot be obtained in [41] where uniform f_T is assumed. Although chain representation of noise is directly related to noise parameters [20], for the directness of physics we will model the base hole noise using hybrid representation as shown in Fig. 1.4. v_h and i_h are the noise source for the hybrid representation, while v_a and i_a are the noise source for the chain representation. The hybrid representation noise is then transformed into chain representation

by [20]

$$\begin{aligned}
S_{va} &= S_{vh} + \frac{S_{ih}}{|Y_{21}|^2} + 2\Re \left[\frac{S_{ihvh^*}}{Y_{21}} \right], \\
S_{ia} &= S_{ih} \left| \frac{Y_{11}}{Y_{21}} \right|^2, \\
S_{iava^*} &= S_{ihvh^*} \frac{Y_{11}}{Y_{21}} + S_{ih} \frac{Y_{11}}{|Y_{21}|^2}.
\end{aligned} \tag{5.8}$$

where the Y-parameters are for the intrinsic transistor *including* r_{bi} .

5.2.2 Model equation derivation

We first use the five resistance model to derive model equations for the base hole noise. The equations include three model parameters R_{bn} , K_1 and K_2 . We then examine the bias dependence of these model parameters using device simulation.

v_h and i_h

To calculate v_h and i_h , we float the base terminal and short the collector terminal to emitter in Fig. 5.6. The base terminal voltage gives v_h and the collector output current gives i_h . Each resistance has $4kTR$ thermal noise. Contributions of each resistance to v_h and i_h can be calculated.

Because of the symmetry of the circuit in Fig. 5.6, the noise of R_3 does not contribute to either v_h or i_h . Each R_1 gives $4kTR_1/4$ noise for v_h . The two R_1 totally contribute $4kTR_1/2$ noise to v_h . Again because of symmetry, R_1 does not contribute to i_h . The two R_2 resistors contribute to both v_h and i_h .

Now consider the left R_2 . We insert a test noise voltage source v_{R2} into Fig. 5.6. v_{R2} has a noise voltage PSD of $4kTR_2$. Solving the symmetric network,

$$v_1 + v_4 = -v_{R2} \frac{C_2}{C_1 + C_2 + j\omega R_2 C_1 C_2}, \quad (5.9)$$

$$v_2 + v_3 = v_{R2} \frac{C_1}{C_1 + C_2 + j\omega R_2 C_1 C_2}. \quad (5.10)$$

The equivalent hybrid representation noise sources for Fig. 5.6 are then obtained as

$$v_h = \frac{v_1 + v_4}{2}, \quad (5.11)$$

$$\begin{aligned} i_h &= -g_{m2}(v_2 + v_3) - g_{m1}(v_1 + v_4) \\ &= \left[\frac{g_{m2}}{C_2} - \frac{g_{m1}}{C_1} \right] C_1 (v_1 + v_4). \end{aligned} \quad (5.12)$$

If the f_T of A_1 and A_2 are the same, i.e., $g_{m2}/C_2 = g_{m1}/C_1$, then $i_h=0$. The base hole noise can be fully described by v_h . As discussed in Section II, $g_{m1}/C_1 < g_{m2}/C_2$, therefore i_h has the same sign as v_h , leading to a positive $\Re(S_{ihvh*})$.

Noise in hybrid representation

For convenience, we define two partition factors

$$\lambda_c = \frac{C_1}{C_1 + C_2} < 1, \quad \lambda_{gm} = \frac{g_{m1}}{g_{m1} + g_{m2}} < 1. \quad (5.13)$$

Note $\lambda_{gm} < \lambda_c$. As $C_2 \ll C_1$, we neglect the $\omega R_2 C_1 C_2$ term in both v_h and i_h . The noise due to the left R_2 can be obtained as

$$\begin{aligned}
S_{v_h, R_2} &= \langle v_h v_h^* \rangle = 4kT R_2 [\lambda_c^2 / 4], \\
S_{i_h, R_2} &= \langle i_h i_h^* \rangle = 4kT R_2 (g_{m1} + g_{m2})^2 (1 - \lambda_c - \lambda_{gm})^2, \\
S_{i_h v_h^*, R_2} &= \langle i_h v_h^* \rangle = 4kT R_2 (g_{m1} + g_{m2}) (1 - \lambda_c) (\lambda_c - \lambda_{gm}).
\end{aligned} \tag{5.14}$$

The right R_2 has the same noise as the left R_2 , therefore the two R_2 contribute two times of the noise shown in (5.14). Now the overall noise can be obtained by adding the contributions of two R_1 and two R_2 in (5.14) as

$$\begin{aligned}
S_{v_h} &= 4kT R_{bn}, \\
S_{i_h} &= 4kT R_{bn} g_m^2 K_1, \\
S_{i_h v_h^*} &= 4kT R_{bn} g_m K_2,
\end{aligned} \tag{5.15}$$

where

$$\begin{aligned}
g_m &= 2(g_{m1} + g_{m2}), R_{bn} = [R_1 + R_2(1 - \lambda_c)^2] / 2, \\
K_1 &= \frac{R_2/2}{R_{bn}} (\lambda_c - \lambda_{gm})^2, K_2 = \frac{R_2/2}{R_{bn}} 2(1 - \lambda_c) (\lambda_c - \lambda_{gm}).
\end{aligned} \tag{5.16}$$

We have lumped R_1 , R_2 , λ_{gm} and λ_c into three model parameters R_{bn} , K_1 and K_2 . The following observations are noted:

- The thermal resistance R_{bn} defined in (5.16) is actually the lumped intrinsic base resistance r_{bi} of Fig. 5.6 . To provide this, we examine the BE input impedance of Fig. 5.6

$$\begin{aligned}
Z_{BE} &= \frac{1}{2} \left[R_1 + \frac{1 + j\omega C_2 R_2}{j\omega(C_1 + C_2) - \omega^2 C_1 C_2 R_2} \right] \\
&\approx \frac{1}{2} \left[R_1 + R_2 \left(\frac{C_2}{C_1 + C_2} \right)^2 \right] + \frac{1}{j\omega(2C_1 + 2C_2)} \\
&= [R_1 + R_2(1 - \lambda_c)^2] / 2 + \frac{1}{j\omega(2C_1 + 2C_2)} \\
&= r_{bi} + \frac{1}{j\omega(2C_1 + 2C_2)}. \tag{5.17}
\end{aligned}$$

(5.17) means that Z_{BE} can be modeled by a resistance in series with total BE capacitance. Such resistance essentially is r_{bi} , and clearly equal to the R_{bn} in (5.16). However, the R_{bn} needed to fit experimental noise data is different from the r_{bi} extracted either based on QS or NQS equivalent circuit as detailed below.

- According to stochastic physics, the normalized correlation should not exceed unity [2], meaning $K_2^2 \leq K_1$. If BE fringe effect is not taken in account, i.e. $\lambda_c = \lambda_{gm}$, then $K_1 = K_2 = 0$. The new model reduces to $4kTR_{bn} \approx 4kTr_{bi}$.

Fig. 5.7 shows the simulated base hole noise in hybrid representation with the new model at $V_{BE}=0.90V$. Note that $\Re(S_{ihvh*}) > 0$, which is consistent with $g_{m1}/C_1 < g_{m2}/C_2$. The spikes at low frequencies can be modeled at extra complexity if g_{be} is included in Fig. 5.6. However, the spikes will disappear in chain representation due to the Y_{11} factor in (5.8), which decreases as frequency decreases.

Fig. 5.8 shows the modeling results in chain representation using (5.8) at $V_{BE}=0.90V$. The new model correctly models S_{va} and $\Im(S_{iava*})$. Note that the simulated S_{ia} and $\Re(S_{iava*})$ are nonzero at low frequencies. They are zero in the new model because g_{be} was neglected. These low frequency errors are negligible compared to the large value of base electron noise and emitter

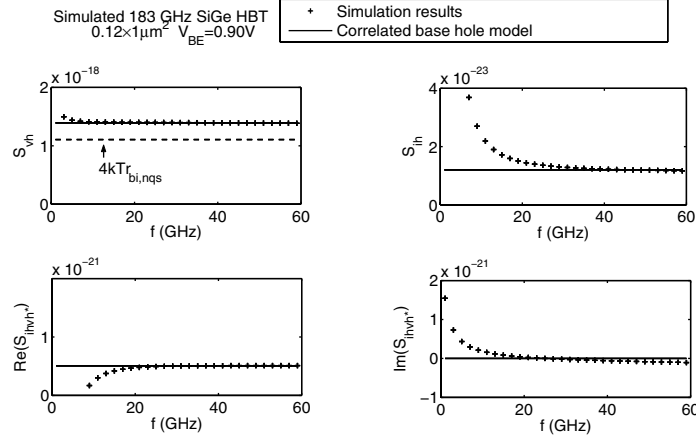


Figure 5.7: Comparison of simulation and new model for base hole noise in hybrid representation at one bias $V_{BE}=0.90V$.

hole noise. S_{va} and $\Im(S_{iava*})$, however, are correctly modeled. The small error in $\Re(S_{iava*})$ is not important as $\Re(S_{iava*}) \ll \Im(S_{iava*})$.

Bias dependence of K_1 and K_2

We need to investigate the bias dependence of K_1 and K_2 because of the unknown bias dependence of λ_c and λ_{gm} . We examined two SiGe HBTs simulated by DESSIS. One has 85 GHz peak f_T and the other has 183 GHz peak f_T .

Fig. 5.9 (a) shows the bias dependence of K_1 for the two simulated devices. K_1 is nearly constant around peak f_T for each device. For low biases, S_{ih} is not important due to small g_m , hence the final noise is not sensitive to K_1 . Further, the new model is proposed to improve noise modeling for biases before f_T roll off, the K_1 value of peak f_T bias can be used for all biases. Fig. 5.9 (b) shows the bias dependence of K_2 for the two devices. Again K_2 is nearly constant around peak f_T . Similarly, the K_2 value of peak f_T bias can be used for all biases. Because of the weak bias dependence of K_1 and K_2 , according to (5.15), S_{ih} and S_{ihv_h*} go to zero at low biases due to small g_m . The correlation of v_h and i_h affects mainly the biases around peak f_T .

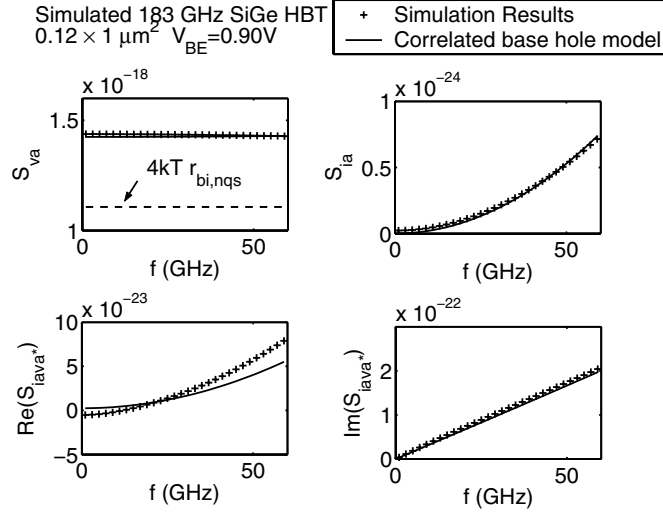


Figure 5.8: Comparison of simulation and new model for base hole noise in chain representation at one bias $V_{BE}=0.90\text{V}$.

5.2.3 R_{bn} , instead of r_{bi} , as base noise resistance

In DESSIS based microscopic noise simulation, the intrinsic base hole noise in hybrid representation can be obtained by integration of hole noise within intrinsic base. R_{bn} can then be determined from $S_{vh}/4kT$ according to (5.15). The R_{bn} obtained is different from r_{bi} , no matter NQS or QS equivalent circuit is used. Fig. 5.13 shows R_{bn} and r_{bi} obtained using simulation for the 183 GHz SiGe HBT. Two different r_{bi} extracted based on QS and NQS equivalent circuits are shown. The QS r_{bi} , extracted using circle method overestimates R_{bn} at low biases and underestimates R_{bn} at biases around peak f_T . The NQS r_{bi} , which is more physical, has a value close to R_{bn} at low biases, however, underestimates R_{bn} at high biases. It can also be observed that R_{bn} has a weak bias dependence. Therefore R_{bn} can be modeled as a constant, whose value can be approximated by the r_{bi} value based on NQS equivalent circuit at *low* biases.

Experimentally, R_{bn} can be extracted by fitting R_n , as detailed below. The difference between R_{bn} and r_{bi} was also observed using noise simulation in [46], where the total base resistance was

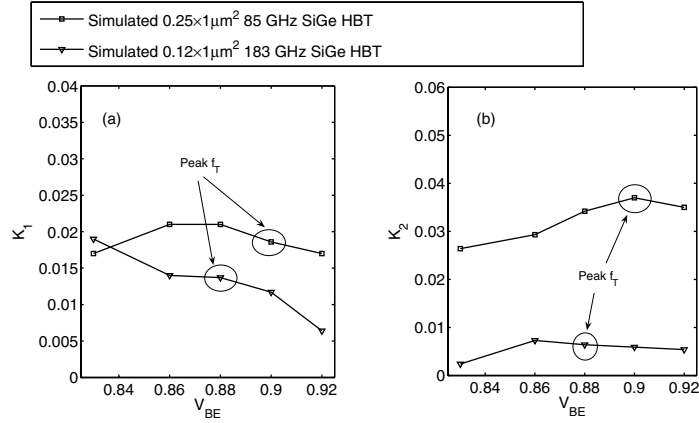


Figure 5.9: (a) K_1 extracted for simulated 85 GHz and 183 GHz peak f_T SiGe HBTs. (b) K_2 extracted for simulated 85 GHz and 183 GHz peak f_T SiGe HBTs

used. To our knowledge, at present, the physics behind such difference is not understood and needs further investigation.

5.3 Improved physical noise model

Our new noise model, the combination of improved electron noise and base hole noise models, can be implemented for SiGe HBTs with four model parameters, τ_c , R_{bn} , K_1 and K_2 . Details are given below.

5.3.1 Implementation technique

S-parameters and noise parameters are measured for SiGe HBTs from three generations of processes. The individual HBTs measured here have peak f_T of 50 GHz, 90GHz and 160 GHz. Note that these experimental devices do not exactly correspond to the DESSIS simulated devices. Two devices of different emitter length from each generation are used, which allow us to investigate emitter length scaling. The S-parameters are measured on-chip using a 8510C Vector Network Analyzer (VNA) from 2-26 GHz. The noise parameters are measured using an ATN NP5 system

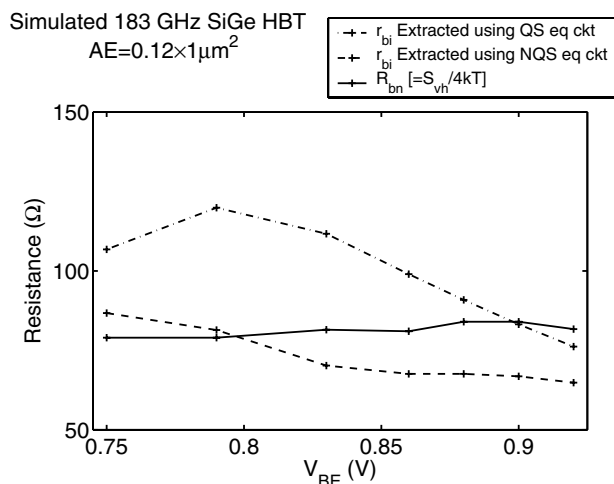


Figure 5.10: Comparison between thermal resistances R_{bn} and small signal resistance r_{bi} .

for the same frequency range. Both S-parameters and noise parameters are de-embedded with standard OPEN/SHORT structures. The measurement is made across a wide biasing current range up to f_T roll off point.

We first determine the equivalent circuit parameters from measured S-parameters for each bias using our direct extraction method described in Chapter 3. Excellent fitting of measured S-parameters is achieved across a wide biasing current range for all of the frequencies measured. The extracted biasing dependence of circuit parameters is consistent with device physics based expectations. The next step is to determine the four noise model parameters τ_c , R_{bn} , K_1 and K_2 . For DESSIS simulation data, they can be extracted directly. For experimental data, their values are determined by fitting the noise parameters. This is achievable as different model parameters affect different noise parameters as detailed below.

5.3.2 Modeling results

In this section, we show the modeling results for three generations of SiGe HBTs respectively. Emitter length scaling is also examined. Finally we summarize the effect of model parameters on noise parameters.

50 GHz SiGe HBTs

Fig. 5.11 shows the noise parameters versus frequency for an emitter area $A_E = 0.24 \times 20 \times 2 \mu\text{m}^2$ SiGe HBT with 50 GHz peak f_T . $I_C=19.4$ mA. The solid line and dot line represent the results of using improved base hole model and electron model with $\tau_c=0$ ps and $\tau_c=0.8$ ps respectively. The dash dot line is calculated using $4kTr_{bi}$ for base hole noise and brutal use of van Vliet model for electron noise. The dash line is the result of using $S_{ib} = 2qI_b$, $S_{ic} = 2qI_c$, which is referred as SPICE model. Fig. 5.12 plots the noise parameters versus I_c for the same

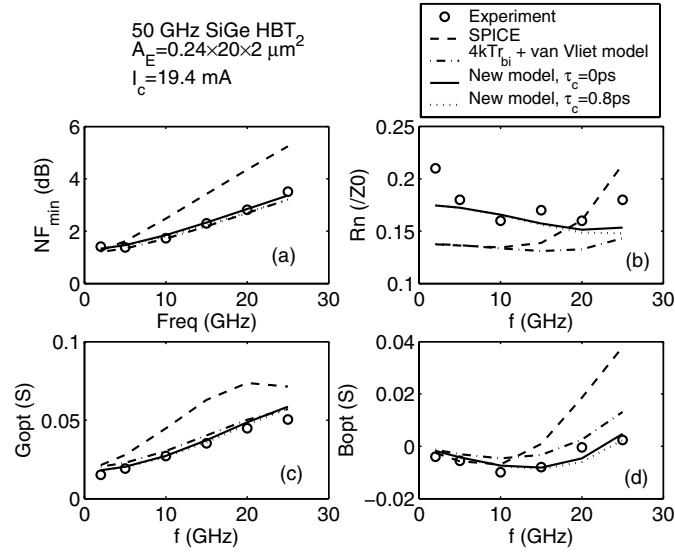


Figure 5.11: Noise parameters versus frequency for $A_E = 0.24 \times 20 \times 2 \mu\text{m}^2$ 50 GHz SiGe HBT at $I_c=19.4$ mA.

device at $f=15$ GHz. The solid line is for the new model. The dash line is for the SPICE model.

The dot dash line is for the brutal use of van Vliet model with $4kTr_{bi}$ hole noise. As shown by

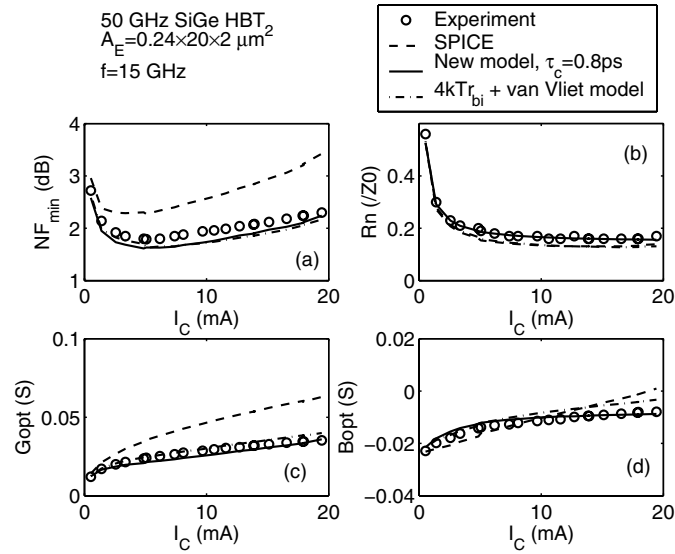


Figure 5.12: Noise parameters versus I_C for $A_E = 0.24 \times 20 \times 2 \mu\text{m}^2$ 50 GHz SiGe HBT at $f = 15 \text{ GHz}$.

Fig. 5.11 and Fig. 5.12, the SPICE model overestimates NF_{min} and G_{opt} . Compared to the van Vliet model with $4kTr_{bi}$, the new model is clearly better in modeling R_n and B_{opt} , and provides excellent fitting for all noise parameters overall. We can make the following observations on the various effects involved:

- CB SCR effect

τ_c has no significant effect. For this device, the total transit time τ_{tr} is 2.1 ps, which is dominated by base transit time. Therefore the brutal use of van Vliet model does not cause noticeable error.

- Fringe BE junction effect

We find the fringe effect mainly affects B_{opt} through correlation parameter K_2 . An inspection of the difference between the solid line and the dash dot line in Fig. 5.11 (d) shows that the

correlation of base hole noise decreases B_{opt} . Fig. 5.12 (d) shows that such reduction can improve B_{opt} modeling at high current levels.

- R_{bn} instead of r_{bi} as base noise resistance

Since we choose small value for K_1 i.e. $K_1 = K_2^2$ as shown in Table 5.2, improvement of R_n fitting is mainly achieved by choosing appropriate R_{bn} value. A bias independent R_{bn} is shown to be enough. Fig. 5.13 shows R_{bn} together with r_{bi} for the device examined. Two different r_{bi} extracted based on QS and NQS equivalent circuits are shown. R_{bn} is close to the low current r_{bi} values and is larger than r_{bi} at high current levels. As shown by Fig. 5.11

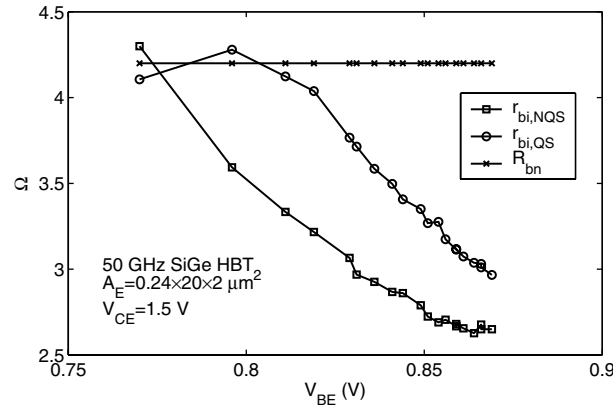


Figure 5.13: Comparison between thermal resistances R_{bn} and small signal resistance r_{bi} .

(b) and Fig. 5.12 (b), a larger R_{bn} increases R_n at all frequencies and all biases. The R_n curve is shifted upward in parallel.

160 GHz SiGe HBTs

Fig. 5.14 shows the noise parameters versus frequency for an $A_E = 0.12 \times 18 \mu\text{m}^2$ 160 GHz peak f_T SiGe HBT. $I_c = 11.7$ mA. The solid line and dot line represent the results of using improved base hole model and electron model with $\tau_c = 0.5$ ps and $\tau_c = 0$ ps respectively. The dash dot line is the result of new model with $K_1 = K_2 = 0$ and $\tau_c = 0.5$ ps. The dash line is the result of SPICE

model. For R_n , the dot line overlaps with the solid line. For G_{opt} , all of the lines almost overlap together and give good fitting. Fig. 5.15 plots the noise parameters versus I_c for the same 160 GHz

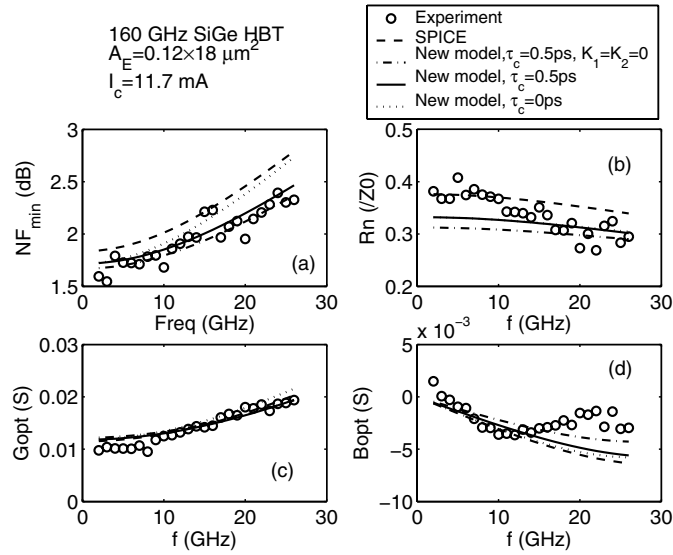


Figure 5.14: Noise parameters versus frequency for $A_E = 0.12 \times 18 \mu\text{m}^2$ 160 GHz SiGe HBT at $I_c = 11.7 \text{ mA}$.

SiGe HBT at $f = 26 \text{ GHz}$. The line meanings are exactly the same as in Fig. 5.14. We can examine the various effects:

- CB SCR effect

Fig. 5.14 (a) shows that τ_c reduces NF_{min} at high frequencies as illustrated by the difference between the solid line and the dot line. Such reduction becomes more significant at high current levels as shown by Fig. 5.15 (a). Actually, the total transit time of this device is 0.58 ps. The 0.5 ps τ_c thus has noticeable impact on NF_{min} .

- Fringe BE junction effect

Comparing the dash dot line and the solid line in Fig. 5.14 (d), we again find that the correlation parameter K_2 reduces B_{opt} . However because of the small value of B_{opt} (< 0.005) for

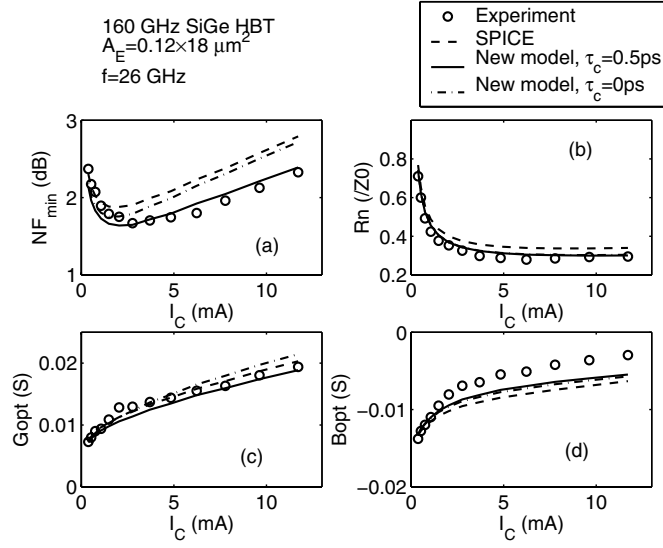


Figure 5.15: Noise parameters versus I_C for $A_E = 0.12 \times 18 \mu\text{m}^2$ 160 GHz SiGe HBT at $f=26$ GHz.

this device, and the noisiness of measurement data, it is difficult to evaluate the importance of the fringe effect.

- R_{bn} instead of r_{bi} as base noise resistance

R_n fitting process shows that we need $R_{bn} < r_{bi}$ for this device. Consequently, the new model gives smaller R_n as shown in Fig. 5.14 (b). The bias dependences for high frequencies are improved, as shown in Fig. 5.15 (b).

90 GHz SiGe HBTs

Fig. 5.16 shows the noise parameters versus frequency for $0.12 \times 20 \times 4$ Fig. 5.17 shows the noise parameters versus I_C for $0.12 \times 20 \times 4$ 90 GHz SiGe HBT at $f=20$ GHz. The impact of CB SCR is between its impacts on the former two generations. The impact of the fringe effect is similar to that observed in 50 GHz device. For this generation, R_{bn} is close to r_{bi} . Overall, the new

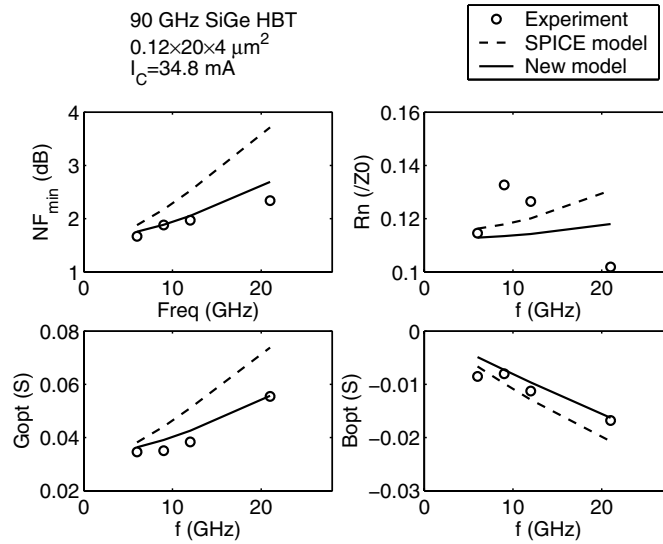


Figure 5.16: Noise parameters versus frequency for $0.12 \times 20 \times 4$ 90 GHz SiGe HBT at $I_C = 34.8$ mA.

model gives excellent noise parameter fittings for all measured frequencies and biases before f_T roll off.

5.3.3 Geometry scaling

Here we examine emitter length (LE) scaling. Ideally, τ_c should be constant versus LE. K_1 and K_2 should be also constant versus LE as the partition factor λ_C and λ_{gm} are independent on LE. R_{bn} should scale closely like a resistance as discussed in [46] using noise simulation. Excellent fittings have been obtained for scaled devices of three generations. Figs. 5.18- 5.20 plots noise parameters versus frequency for scaled 50 GHz, 90 GHz and 160 GHz devices respectively. The solid line is the result of a high bias and the dash line is the result of a low bias. The experimental data has been well modeled for both biases of each generation.

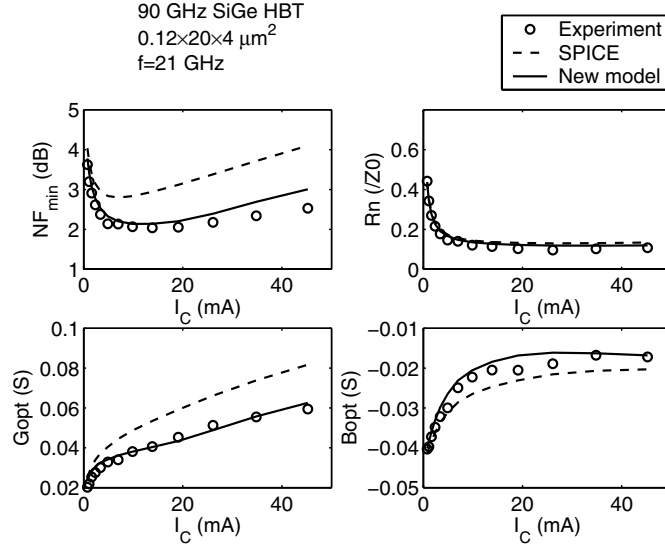


Figure 5.17: Noise parameters versus I_C for $0.12 \times 20 \times 4$ 90 GHz SiGe HBT at $f=20$ GHz.

5.3.4 Model parameter impacts and extraction guidelines

- τ_c reduces high frequency NF_{min} for high biases as shown by Fig. 5.14 (a) and Fig. 5.15 (a). It has more significant effect for highly scaled generations where $\tau_c > \tau_b$. The initial value can be estimated with τ_{tr} . Its final value can be determined by NF_{min} fitting.
- R_{bn} mainly affects R_n for all frequencies and all biases. How R_{bn} compares to r_{bi} depends on technology generation as shown by Fig. 5.12 (b) and Fig. 5.15 (b). Its initial value can be estimated with r_{bi} at low current levels, and finally determined by R_n fitting.
- K_2 reduces B_{opt} for high biases and has little effect on other parameters as shown by Fig. 5.12. K_2 , which involves λ_C , λ_{gm} and R_2/R_{bn} can be estimated with simulation. Experimentally, a small value, e.g. 0.01, should be used as initial guess. Its final values is determined by high current level B_{opt} fitting.

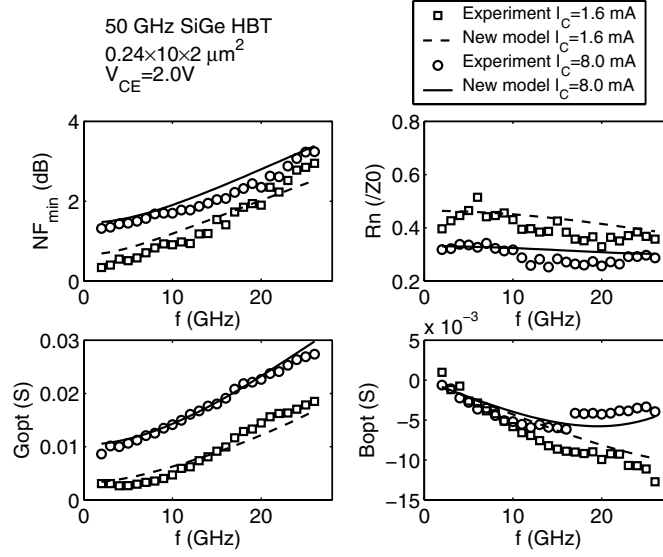


Figure 5.18: Noise parameters versus frequency for scaled 50 GHz SiGe HBTs ($A_E = 0.24 \times 10 \times 2 \mu\text{m}^2$).

- K_1 can increase NF_{min} and R_n as shown by Fig. 5.14 (a) and (b). However, in model implementation, we choose $K_1 = K_2^2$ to simplify parameter determination, which is generally satisfactory.

Table 5.2 summarizes the model parameters for the previous results. r_{bi} and r_{bx} are also shown.

Table 5.2: Model parameters, r_{bi}^* and r_{bx}^* for reference

f_T GHz	Device μm^2	τ_c ps	K_1 -	K_2 -	R_{bn} Ω	r_{bi}^* Ω	r_{bx}^* Ω
50	$0.24 \times 10 \times 2$	0.8	0.002	0.045	6.2	5.4	3.75
	$0.24 \times 20 \times 2$				4.2	2.7	2.4
90	$0.12 \times 8 \times 4$	0.8	0.02	0.1	3.0	3.0	1.52
	$0.12 \times 20 \times 4$				1.2	1.2	3.67
160	0.12×12	0.5	0.02	0.1	7.5	11.1	6.10
	0.12×18				4.0	7.0	4.77

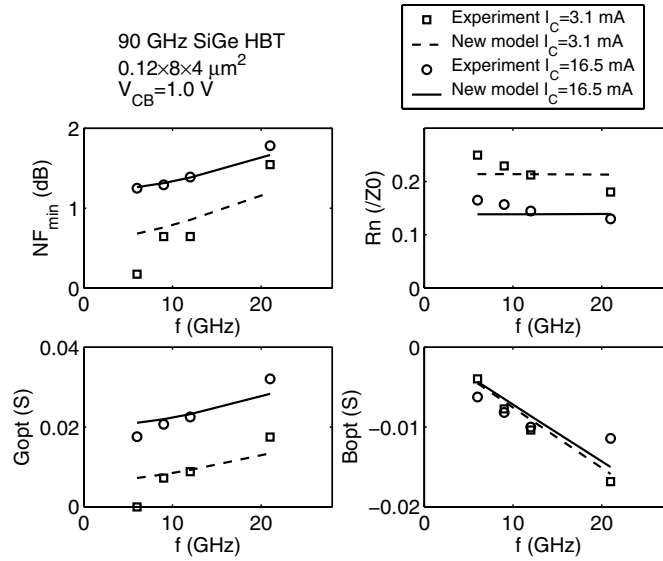


Figure 5.19: Noise parameters versus frequency for scaled 90 GHz SiGe HBTs ($A_E = 0.12 \times 8 \times 4 \mu\text{m}^2$).

5.4 Summary

We have presented an improved RF noise model for SiGe HBTs using NQS equivalent circuit. The van Vliet model has been extended to include both emitter hole noise and CB SCR effect for modern BJTs. The CB SCR delay time decreases high frequency NF_{min} for high biases. The base hole noise is modeled by a noise voltage source and a correlated noise current source in hybrid representation due to fringe BE junction effect. The correlation between two noise sources decreases B_{opt} . The base noise resistance R_{bn} is not always the same as the intrinsic base resistance r_{bi} , which cannot be explained by fringe effect. Model parameter extraction guidelines are given. The utility of the model has been demonstrated using experimental data of SiGe HBTs from three generations.

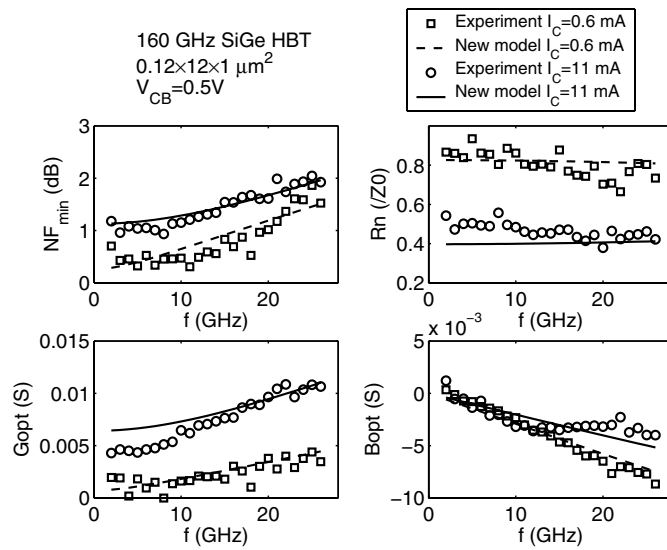


Figure 5.20: Noise parameters versus frequency for scaled 160 GHz SiGe HBTs ($A_E = 0.12 \times 12 \mu\text{m}^2$).

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APPENDIX A

REPRESENTATION TRANSFORMATION FOR TWO-PORT NETWORK

A.1 T-matrix for noise representation transformation

Table A.1: Transformation Matrices to Calculate Noise Matrices

T		Original Representation					
		Y-		Z-		A-	
Resulting	Y-	$\begin{bmatrix} 1 & 0 \\ 0 & 1 \end{bmatrix}$		$\begin{bmatrix} Y_{11} & Y_{12} \\ Y_{21} & Y_{22} \end{bmatrix}$		$\begin{bmatrix} -Y_{11} & 1 \\ -Y_{21} & 0 \end{bmatrix}$	
	Z-	$\begin{bmatrix} Z_{11} & Z_{12} \\ Z_{21} & Z_{22} \end{bmatrix}$		$\begin{bmatrix} 1 & 0 \\ 0 & 1 \end{bmatrix}$		$\begin{bmatrix} 1 & -Z_{11} \\ 0 & -Z_{21} \end{bmatrix}$	
	A-	$\begin{bmatrix} 0 & A_{12} \\ 1 & A_{22} \end{bmatrix}$		$\begin{bmatrix} 1 & -A_{11} \\ 0 & -A_{21} \end{bmatrix}$		$\begin{bmatrix} 1 & 0 \\ 0 & 1 \end{bmatrix}$	

A.2 Derivation of Noise Parameters

According to (1.4), we have

$$NF = \frac{S_s/N_s}{S_o/N_o} = \frac{N_o}{N_s G} = 1 + \frac{N_{added}}{N_s G} = 1 + \frac{N_{added}/G}{N_s}. \quad (\text{A.1})$$

This means that NF can be calculated at *any point* of circuit by 1 plus a ratio (Noise added by two-port network divided by noise from signal source). Fig. A.1 shows the circuit configuration used for derivation. We denote the input admittance of the two-port network as Y_I . $Y_S = G_S + jB_S$.

We choose node B for derivation.

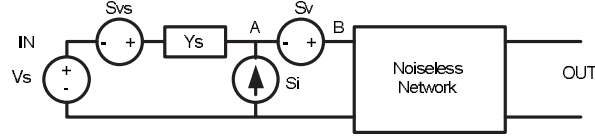


Figure A.1: Noise Figure

We have

$$v_{added} = v_a \frac{Y_S}{Y_I + Y_S} + \frac{i_a}{Y_I + Y_S}, \quad v_s = \frac{i_s}{Y_I + Y_S}.$$

which means

$$N_{added} \equiv \langle v_{added} v_{added}^* \rangle = S_v \left| \frac{Y_S}{Y_I + Y_S} \right|^2 + \frac{S_i}{|Y_I + Y_S|^2} + \frac{2\Re(Y_S^* S_{iv}^*)}{|Y_I + Y_S|^2},$$

$$N_s \equiv \langle v_s v_s^* \rangle = \frac{4kT \Re(Y_S)}{|Y_I + Y_S|^2} = \frac{4kT G_S}{|Y_I + Y_S|^2}.$$

Therefore

$$NF = 1 + \frac{S_v}{4kT G_S} \left[\frac{S_i}{S_v} + 2\Re \left(Y_S^* \frac{S_{iv}^*}{S_v} \right) + |Y_S|^2 \right] \quad (A.2)$$

With some algebra manipulation, (A.2) can be simplified into (1.5) with relations in (1.8). Note that generally we have two opposite values for G_{opt} from a square root, however only the positive value is chosen because of the resistivity of signal source admittance.

APPENDIX B

APPROXIMATION OF INTRINSIC BASE RESISTANCE NOISE CONSIDERING CURRENT CROWDING EFFECT

B.1 General Principles

The approximation for the intrinsic base resistance noise current PSD, S_{irbi} , is based on J. C. J. Paasschens's theoretical analysis of BJT noise considering both *dc* and *ac* crowding [41]. In [41], the intrinsic base resistance noise was described using $V_{B_x B_i}$, the *dc* voltage drop across the equivalent base resistance representing *dc* current crowding. To avoid $V_{B_x B_i}$ extraction, we relate the intrinsic base resistance noise to its small signal value r_{bi} and *dc* current I_B . This is helpful when modeling noise based on small signal equivalent circuit.

Carefully observing the I_B and S_{irbi} expressions for both circular and rectangular emitter BJTs, (see (37), (41), (52) and (56) in [41]), we found that all these terms are inversely proportional to R_{BV} and the remaining part of these expressions excluding R_{BV} only depends on $V_{B_x B_i}$. Here R_{BV} is the low current limit of $V_{B_x B_i}/I_B$. Therefore we can make an approximation for S_{irbi} using a linear combination of $4kTg_{bi}$ and qI_B as

$$S_{irbi,appr} = (\lambda_1 4kTg_{bi} - \lambda_2 qI_B)\Delta f. \quad (\text{B.1})$$

where $g_{bi} = 1/r_{bi}$. Note that the error is *independent* of R_{BV} . Therefore the two coefficients are general for any crowding strength. In the following we will obtain these two coefficients for circular and rectangular emitters respectively.

B.2 Circular Emitter BJT

For circular emitter BJT [41],

$$I_B = \frac{V_T(e^{V_{B_x B_i}/V_T} - 1)}{R_{BV}}. \quad (\text{B.2})$$

g_{bi} is obtained by

$$g_{bi} = \frac{dI_B}{dV_{B_x B_i}} = \frac{e^{V_{B_x B_i}/V_T}}{R_{BV}}. \quad (\text{B.3})$$

The base resistance noise is given in (2.75) by [41] Substitute (B.2), (B.3) and (2.75) into (B.1), one has

$$4\lambda_1 + \lambda_2 = 10/3, \quad (\text{B.4})$$

$$\lambda_2 = 2/3. \quad (\text{B.5})$$

This gives $\lambda_1 = 1$ and $\lambda_2 = 2/3$. Therefore, we get an exact expression for S_{irbi} as

$$S_{irbi,appr} = [4kT/r_{bi} - 2qI_B/3] \Delta f. \quad (\text{B.6})$$

To make (B.6) positive, we need

$$r_{bi} < 6(V_T/I_B) = 6r_{\pi,e}.$$

This is easily satisfied in practice.

B.3 Rectangular Emitter BJT

For rectangular emitter BJT [41],

$$I_B = \frac{2V_T(e^{V_{B_x B_i}/V_T} - 1) + V_{B_x B_i}}{3R_{BV}}. \quad (\text{B.7})$$

g_{bi} is thus

$$g_{bi} = \frac{dI_B}{dV_{B_x B_i}} = \frac{2e^{V_{B_x B_i}/V_T} + 1}{3R_{BV}}. \quad (\text{B.8})$$

The noise S_{irbi} is given in (2.76) by [41] If $V_{B_x B_i} \gg V_T$, S_{irbi} will be proportional to $e^{V_{B_x B_i}/V_T}$, the same as I_B and g_{bi} . Therefore the error using approximation (B.1) at large $V_{B_x B_i}$ will saturate to a constant. Because of the exponential term, $V_{B_x B_i} = 10V_T$ is sufficient to cause such saturation of error. Therefore we only need to consider $V_{B_x B_i} \in [0, 10V_T]$. We optimize λ_1 and λ_2 to minimize the error defined by

$$Err = |(S_{irbi,theory} - S_{irbi,appr})/S_{irbi,theory}|.$$

We found $\lambda_1 = 1.0149$ and $\lambda_2 = 0.6772$. The solid line in Fig. B.1 shows the error from approximations. The error is smaller than 1.5% for all $V_{B_x B_i}$. These two coefficients are very close to the values of the circular case. The dash line in Fig. B.1 shows the error using $\lambda_1 = 1$ and $\lambda_2 = 2/3$. The error is less than 3%. Therefore we can unify these two cases using (B.6) with little loss in accuracy. Fig. B.2 shows the ratio of calculated noise to the theoretical noise using this method and traditional $4kT/r_{bi}$ method. The error has been much decreased using the proposed method. For the SiGe HBTs used in this work, $V_{B_x B_i}/V_T$ is less than 0.8 at peak f_T , making the crowding effect indeed unimportant for practical purposes. This is in part by design, as the HBTs are typically designed to keep the crowding effect under control.

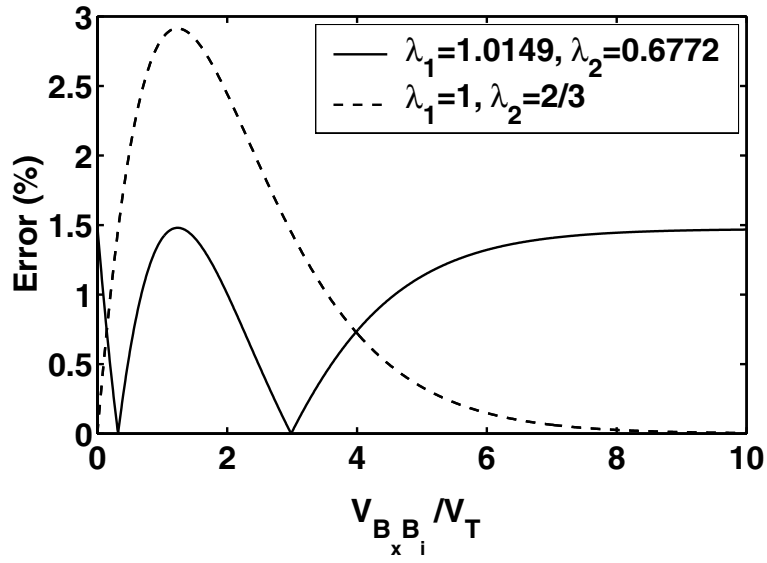


Figure B.1: Approximation induced error versus $V_{B_x B_i}$ for rectangular emitter BJT.

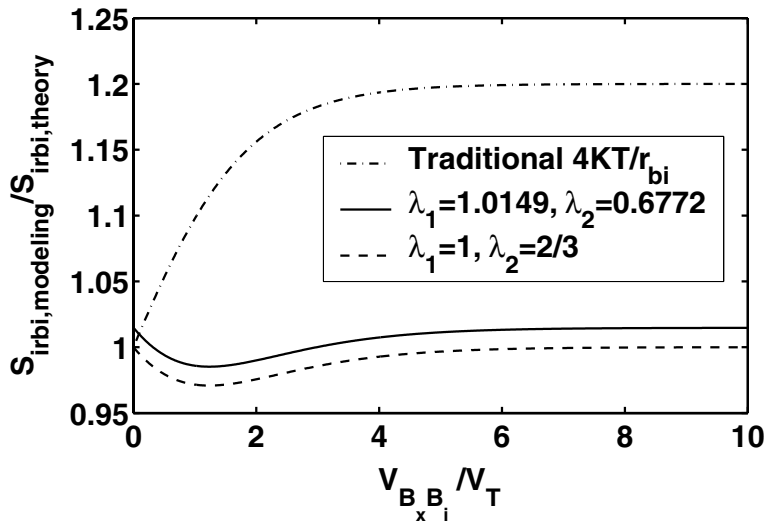


Figure B.2: Comparison between approximation method and the traditional $4kT/r_{bi}$ method for rectangular emitter BJT.

APPENDIX C

DERIVATION OF NQS DELAY TIME WITH CB SCR

We can drive (3.3) by approximating (3.2) with the functional form of (3.1) using Taylor expansion analysis method. We use Arabic numeral subscripts to indicate the order of the Taylor expansion coefficients, as was done in Section III. The first order coefficients for $\mathfrak{S}(Y_{11})$ without and with CB SCR delay are

$$\begin{aligned}\mathfrak{S}(Y_{11}^{bs})_1 &= C_{bej} + C_{bed}^b, \\ \mathfrak{S}(Y_{11}^{al})_1 &= C_{bej} + C_{bed}^b + g_m \tau_c \equiv C_{bej} + C_{bed},\end{aligned}\tag{C.1}$$

respectively. (C.1) means $C_{bed} = C_{bed}^b + g_m \tau_c$. With the definitions of τ_{tr} and τ_{tr}^b , we obtain the τ_{tr} expression in (3.3). The second order coefficients of $\mathfrak{R}(Y_{21})$ for the base and the whole intrinsic transistor are

$$\begin{aligned}\mathfrak{R}(Y_{21}^{bs})_2 &= g_m \tau_{tr}^b \tau_{in}^b, \\ \mathfrak{R}(Y_{21}^{al})_2 &= g_m \tau_{tr} \left[\tau_{in}^b + \tau_c \frac{\tau_{out}^b + 2\tau_c/3}{\tau_{tr}} \right] \equiv g_m \tau_{tr} \tau_{in}.\end{aligned}\tag{C.2}$$

(C.2) directly gives the τ_{in} expression in (3.3). Similarly, by comparing $\mathfrak{S}(Y_{21}^{bs})_1$ and $\mathfrak{S}(Y_{21}^{al})_1$, we have $\tau_{in} + \tau_{out} = \tau_{in}^b + \tau_{out}^b + \tau_c$. With the τ_{in} expression already known, the τ_{out} expression in (3.3) can then be obtained through subtraction.

APPENDIX D

ANALYTICAL Y-PARAMETERS

In the following, we derive the analytical Y-parameters for different blocks related to the small signal equivalent circuit in Fig. 3.4 using two methods.

D.1 Manual Derivation of Analytical Y-parameters

We define Y_I and G_M as

$$Y_I \equiv g_{be} + j\omega C_{bej} + \frac{j\omega C_{bed}}{1 + j\omega C_{bed} r_d}, \quad G_M \equiv g_m e^{-j\omega \tau_d}. \quad (D.1)$$

We have

$$Y_{11}^{BI} = Y_I + j\omega C_{bci}, \quad Y_{12}^{BI} = -j\omega C_{bci}, \quad Y_{21}^{BI} = G_M - j\omega C_{bci}, \quad Y_{22}^{BI} = j\omega C_{bci}. \quad (D.2)$$

then

$$\begin{aligned} Y_{11}^{BIR} &= \frac{Y_I + j\omega C_{bci}}{1 + Y_I r_{bi} + j\omega C_{bci} r_{bi}}, & Y_{12}^{BIR} &= \frac{-j\omega C_{bci}}{1 + Y_I r_{bi} + j\omega C_{bci} r_{bi}}, \\ Y_{21}^{BIR} &= \frac{G_M - j\omega C_{bci}}{1 + Y_I r_{bi} + j\omega C_{bci} r_{bi}}, & Y_{22}^{BIR} &= \frac{j\omega C_{bci}(1 + Y_I r_{bi} + G_M r_{bi})}{1 + Y_I r_{bi} + j\omega C_{bci} r_{bi}}. \end{aligned} \quad (D.3)$$

We further define

$$\begin{aligned} \Delta &\equiv Y_{11}^{BIR} Y_{22}^{BIR} - Y_{12}^{BIR} Y_{21}^{BIR} + j\omega C_{bcx} (Y_{11}^{BIR} + Y_{22}^{BIR} + Y_{12}^{BIR} + Y_{21}^{BIR}) + j\omega C_{bcx} Y_{22}^{BIR} - \omega^2 C_{bcx} C_{bcx} \\ T &\equiv 1 + Y_{11}^{BIR} r_{bx} + Y_{22}^{BIR} r_c + \Delta r_{bx} r_c + j\omega (r_{bx} C_{bcx} + r_{bx} C_{bcx} + r_c C_{bcx}), \end{aligned} \quad (D.4)$$

we have

$$\begin{aligned}
 Y_{11}^{BM} &= \frac{Y_{11}^{BIR} + j\omega C_{bex} + j\omega C_{bcx} + \Delta r_c}{T}, & Y_{12}^{BM} &= \frac{Y_{12}^{BIR} - j\omega C_{bcx}}{T}, \\
 Y_{21}^{BM} &= \frac{Y_{21}^{BIR} - j\omega C_{bcx}}{T}, & Y_{22}^{BM} &= \frac{Y_{22}^{BIR} + j\omega C_{bex} + \Delta r_{bx}}{T}.
 \end{aligned}
 \tag{D.5}$$

D.2 MATLAB Code for Analytical Y-parameters Derivation

For the Taylor expansion analysis, g_{be} is neglected.

```

% w    -- omega
% gbe  -- EB conductance
% Cd   -- EB diffusion capacitance
% Cj   -- EB depletion capacitance
% Cs   -- Cbci, Ci is a reserved symbol of MATLAB
% Cx   -- Cbcx
% Cbex -- extrinsic EB capacitance
% gm   -- transconductance
% t    -- total output delay time (tau_in+tau_out)
% Rb   -- rbi
% Rd   -- delay resistance rd
% Rc   -- rci+rcx
% Rx   -- rbx

clear all;
syms w gbe Cd Cj Cs Cx Cbex gm t Rb Rd Rc Rx real
YI=j*w*Cd/(1+j*w*Rd*Cd)+j*w*Cj;%+gbe;
GM=gm*exp(-j*w*t);
Ybci=j*w*Cs;
Ybcx=j*w*Cx;
Y=[YI+Ybci -Ybci
   GM-Ybci Ybci];
% Y -- Y-parameters of BI block

Z=inv(Y);
Z(1,1)=Z(1,1)+Rb;
% Z -- Z-parameters of BIR block

YY=inv(Z);
YY(1,1)=YY(1,1)+Ybcx+j*w*Cbex;
YY(1,2)=YY(1,2)-Ybcx;
YY(2,1)=YY(2,1)-Ybcx;
YY(2,2)=YY(2,2)+Ybcx;
simple(YY);
% YY -- Y-parameters of BM block without rbx

detYY=YY(1,1)*YY(2,2)-YY(1,2)*YY(2,1);
T=1+Rx*YY(1,1);
YYx(1,1)=YY(1,1)/T;
YYx(2,2)=(YY(2,2)+Rx*detYY)/T;
YYx(1,2)=YY(1,2)/T;

```

```

YYx(2,1)=YY(2,1)/T;
% YYx -- Y-parameters of BM block with rbx

detYY=YY(1,1)*YY(2,2)-YY(1,2)*YY(2,1);
T=1+Rx*YY(1,1)+Rc*YY(2,2)+detYY*Rx*Rc;
YYY(1,1)=(YY(1,1)+Rc*detYY)/T;
YYY(2,2)=(YY(2,2)+Rx*detYY)/T;
YYY(1,2)=YY(1,2)/T;
YYY(2,1)=YY(2,1)/T;
ZZZ=inv(YYY);
% YYY/ZZZ -- Y/Z-parameters of BX block

```

D.3 MATLAB code for Taylor expansion

For (3.8)-(3.10),

```

AA=1/(ZZZ(2,2)-ZZZ(2,1));
BB=1/ZZZ(1,2);

imAA=taylor(imag(AA),w,2);
simple(imAA);
pretty(imAA);
% imAA -- the first order coefficient of Im(AA)

reAA=taylor(real(AA),w,3);
simple(reAA);
pretty(reAA);
% reAA -- the second order coefficient of Re(AA)

reBB=taylor(real(BB),w,1);
simple(reBB);
% reBB -- the zero order coefficient of Re(BB)

```

For (3.13)-(3.15) and (3.17)

```

imAA=taylor(imag(YYx(1,1)+YYx(1,2)),w,2);
simple(imAA);
pretty(imAA);
% imAA -- the first order coefficient of Im(Y11^BM+Y12^BM)

imAA=taylor(imag(YYx(2,1)-YYx(1,2)),w,2);
simple(imAA);
pretty(imAA);
% imAA -- the first order coefficient of Im(Y21^BM-Y12^BM)

imAA=taylor(imag(YYx(2,2)),w,2);
simple(imAA);
pretty(imAA);
% imAA -- the first order coefficient of Im(Y22^BM)

reAA=taylor(real(YYx(1,1)+YYx(1,2)),w,3);
simple(reAA);
pretty(reAA);
% imAA -- the second order coefficient of Re(Y11^BM+Y12^BM)

```

For (3.21)-(3.22), g_{be} should be added, then the Y-parameters should be re-calculated.

```

imAA=taylor(imag(Y(1,1)+Y(1,2)),w,2);
simple(imAA);
pretty(imAA);
% imAA -- the first order coefficient of Im(Y11^BI+Y12^BI)

imAA=taylor(imag(Y(2,1)-Y(1,2)),w,2);
simple(imAA);
pretty(imAA);
% imAA -- the first order coefficient of Im(Y21^BI-Y12^BI)

reAA=taylor(real(Y(1,1)),w,1);
simple(reAA);
pretty(reAA);
% imAA -- the zero order coefficient of Re(Y11^BI)

reAA=taylor(real(Y(1,1))-gbe,w,3);
simple(reAA);
pretty(reAA);
% imAA -- the second order coefficient of Re(Y11^BI)

```

APPENDIX E

MATLAB CODE FOR SMALL SIGNAL PARAMETER EXTRACTION

The following MATLAB code extracts the small signal parameters for a 50 GHz SiGe HBT

with $A_E = 0.24 \times 20 \times 2 \mu\text{m}^2$.

```

HasCbi=0; % Cbi is the crowding cap paralleled with rbi. 0: no Cbe
HasCrowdingnoise=0; % 0: Sirbi=4kT/rbi, otherwise 4kT/rbi-2qIb/3

% Data: Fixed Vce=1.5 V, Vbe=0.77-0.869 V, freq 2-26 GHz, num_bias=20;
% Data: peakfT 50GHz at bias 19. Ae=0.24x20x2 um^2. Open de-embedded.

load_data_26G;
f=Y_cell_exp{step}(:,1); Omega=2*pi*f;

%=====Deembedding Lb Lc Le =====
for step=1:1:num_bias
    Lb(step)=4.8e-11;
    Lc(step)=4.8e-11;
    Le(step)=1.12e-11;
    Ydlc=Y_cell_exp{step}(:,2:5);
    Zdlc=Y_to_Z(Ydlc);
    Zdlc(:,1)=Zdlc(:,1)-j*Omega*Lb(step)-j*Omega*Le(step);
    Zdlc(:,4)=Zdlc(:,4)-j*Omega*Lc(step)-j*Omega*Le(step);
    Zdlc(:,2)=Zdlc(:,2)-j*Omega*Le(step);
    Zdlc(:,3)=Zdlc(:,3)-j*Omega*Le(step);
    Ydlc=Z_to_Y(Zdlc);
    Y_cell_exp{step}(:,2:5)=Ydlc;
end;

%===De Ccs rcs =====
for step=1:1:num_bias
    Ccs(step)=1.80e-14; % obtained from cold measurement
    Rcs(step)=180; % obtained from cold measurement
    Ccs2(step)=0;
    Y=Y_cell_exp{step}(:,2:5);
    Ys=j.*Omega.*Ccs(step)./(1+j.*Omega.*Ccs(step).*Rcs(step));
    Y(:,4)=Y(:,4)-Ys;
    Y_cell_exp{step}(:,2:5)=Y;
end;

%== extract Re =====
for step=1:1:num_bias
    Ybeta=Y_cell_exp{step}(:,2:5);
    Zbeta=Y_to_Z(Ybeta);
    z12(step)=real(Zbeta(1,2));

```

```

        y21(step)=real(Ybeta(1,3));
        %plot(Omega,real(Ybeta(:,3))); hold on;
end;
%   ben=17; enn=18;
%   xx=1./Ic_tmp;%;
%   k_b=polyfit(xx(ben:enn),z12(ben:enn),1); %intercept gives Re
%   plot(xx,re_gm,xx,xx.*k_b(1)+k_b(2),'+-'); hold on;

%== De-embed Re, extract Cbct tt gm =====
for step=1:1:num_bias
    Re(step)=0.66; % determined from above method
    Y=Y_cell_exp{step}(:,2:5);
    Y=com_Y_re(Y,-Re(step));
    Y_cell_exp{step}(:,2:5)=Y;
    Z=Y_to_Z(Y);
    H=Z(:,4)-Z(:,3);
    G=Z(:,1)-Z(:,2);
    Q=Z(:,2)-Z(:,3);
    k_b=linefit(Omega,imag(1./H),1,20,1,0,'+-','r');
    Cbct(step)=k_b(1);
    k_b=linefit(Omega.^2,real(1./H),1,20,-1,0,'+-','r');
    tt(step)=k_b(1)/Cbct(step)^2;
    k_b=linefit(Omega.^2,real(1./Z(:,2)),5,15,1,0,'+-','r');
    gm0(step)=k_b(2);
end;
% smooth tt (for rcx)
tt(1)=tt(2);
tt(5:num_bias)=tt(5:num_bias).*0+tt(4);
tt=fitcurv(tt.',0.3)';

%==== De Rcx =====
for step=1:1:num_bias
    Rcx(step)=tt(step);
    Y=Y_cell_exp{step}(:,2:5);
    Y=com_Y_rc(Y,-Rcx(step));
    Y_cell_exp{step}(:,2:5)=Y;
end;

%===taylor method for Rbx ====
for step=1:1:num_bias
    Y=Y_cell_exp{step}(:,2:5);
    %--imag y12
    k_b=linefit(Omega.^2,imag(Y(:,2))./Omega,1,5,1,0,'+-','r');
    Cbctt(step)=-k_b(2);
    %--imag y11
    k_b=linefit(Omega.^2,imag(Y(:,1))./Omega,1,3,1,0,'+-','r');
    Ct(step)=k_b(2);
    %--real Y12
    k_b=linefit(Omega.^2,real(Y(:,2)),1,2,-1,0,'+-','r');
    ReY12_2(step)=-k_b(1);
    %--imag Y22
    k_b=linefit(Omega.^2,imag(Y(:,4))./Omega,1,4,1,0,'+-','r');
    ImY22_1(step)=k_b(2);
    %--real Y21
    k_b=linefit(Omega.^2,real(Y(:,3)),1,4,1,0,'+-','r');
    gm(step)=k_b(2);
    %--imagY2112

```

```

k_b=linefit(Omega,imag(Y(:,3)-Y(:,2)),1,5,-1,0,'+-','r');
ImY2112(step)=-k_b(1);
%--real Y11+Y12
k_b=linefit(Omega.^2,real(Y(:,1)+Y(:,2)),1,5,1,0,'+-','r');
ReY1112(step)=k_b(1);
end;

%==== Extract Rbx Cbex Cbcx Cbci ====
k_b=linefit(gm0.*Cbct,ImY22_1,1,8,1,0,'+', 'r');      Rx_rRi=k_b(1);
k_b=linefit(Ct-Cbct,ImY2112./gm0,1,num_bias,1,0,'+', 'b');Rx_Ri=k_b(1);

r=0.3; % Cbci/Cbct, extracted from cold measurement

Ri=(Rx_Ri-Rx_rRi)/(1-r); Rx=Rx_Ri-Ri;
Cbcx=Cbct.*(1-r);      Cbci=Cbct.*r;
k_b=linefit(gm0,Ct-Cbct,1,8,1,0,'+', 'b');          cj=k_b(2);
k_b=linefit(gm0,ReY1112,2,3,1,0,'+', 'r');          test=k_b(2);
aa=Ri; bb=r.*Ri.*Cbct; cc=-test+Rx.*cj.*(cj+Cbct);
xx=(-bb+sqrt(bb.^2-4.*aa.*cc))./(2.*aa);
Cbex=(Cbct-Cbct+cj-xx(1));
Cbej=cj-Cbex;

%==== De Rbx Cbcx Cbex =====
for step=1:1:num_bias
    Rbx(step)=Rx;
    Y=Y_cell_exp{step}(:,2:5);
    Y=com_Y_rb(Y,-Rbx(step));
    Y=Y-[j*Omega*Cbcx(step) -j*Omega*Cbcx(step)...
        -j*Omega*Cbcx(step) j*Omega*Cbcx(step)];
    rbi_QSx(step)=circle(1./Y(:,1));
    Y(:,1)=Y(:,1)-j.*Omega.*Cbex(step);
    rbi_QS(step)=circle(1./Y(:,1));
    Y_cell_exp{step}(:,2:5)=Y;
end;

%==== Extract and de go =====
for step=1:1:num_bias
    Y=Y_cell_exp{step}(:,2:5);
    go(step)=0;%real(Y(1,4));
    %figure(100); plot(Omega,real(Y(:,4)),Omega,Omega-Omega+go(step));
    Y(:,4)=Y(:,4)-go(step);      Y_cell_exp{step}(:,2:5)=Y;
end;

%%==== Extraction for QS rbi and intrinsic para=====
%--de-embed rbi_QS, then extract gbe, gm ,Cbet and Taud
for step=1:1:num_bias
    Y=Y_cell_exp{step}(:,2:5);
    Y=com_Y_rb(Y,-rbi_QS(step));
    y11=Y(:,1)+Y(:,2);
    y21=Y(:,3)-Y(:,2);
    %--- Cbet_QS
    ben=1; enn=15;
    k_b=polyfit(Omega(ben:enn).^2,imag(y11(ben:enn))./Omega(ben:enn),1);
    %plot(Omega.^2,imag(y11)./Omega,Omega.^2,Omega.^2*k_b(1)+k_b(2));
    Cbet_QS(step)=k_b(2);
    %--- gm_QS
    ben=1; enn=15;

```



```

k_b=polyfit(Omega(ben:enn).^2,real(y21(ben:enn)),1);
%plot(Omega.^2,real(y21),Omega.^2,Omega.^2*k_b(1)+k_b(2)); hold on;
gm_QS(step)=k_b(2);
%--- gbe_QS
ben=1; enn=5;
k_b=polyfit(Omega(ben:enn).^2,real(y11(ben:enn)),1);
%plot(Omega.^2,real(y11),Omega.^2,Omega.^2*k_b(1)+k_b(2)); hold on;
gbe_QS(step)=k_b(2);
%--- Taud_QS
ben=1; enn=15;
k_b=polyfit(Omega(ben:enn).^2,imag(y21(ben:enn))./Omega(ben:enn),1);
%plot(Omega.^2,imag(y21)./Omega,Omega.^2,Omega.^2*k_b(1)+k_b(2));
Taud_QS_old(step)=-k_b(2)/gm_QS(step);
%plot(Omega,-imag(log(y21))./Omega); hold on;
k_b=slopefit(Omega(ben:enn),imag(y21(ben:enn)));
Taud_QS_old(step)=-k_b/gm_QS(step);
%plot(Omega,imag(y21),Omega,Omega*k_b); hold on;
end;
Taud_QS_old(1)=Taud_QS_old(2);
Taud_QS=fitcurv(Taud_QS_old',1)';
gbe_QS=Ib_tmp./0.026;
%%%====Extraction for QS end====

%==== NQS tau extraction =====
for step=1:1:num_bias
    Y=Y_cell_exp{step}(:,2:5);
    Z=Y_to_Z(Y);
    H=Z(:,4)-Z(:,3);
    Q=Z(:,2)-Z(:,3);
    k_b=linefit(Omega.^2,real(H./Q),1,20,1,0,'+-','r');
    ReHQ(step)=-k_b(1).*gm0(step);
    k_b=linefit(Omega,imag(H./Q),1,20,-1,0,'+-','r');
    ImHQ(step)=k_b(1).*gm0(step);
end;
k_b=linefit(gm0,ImHQ,1,6,1,0,'+', 'r');
Cbei0=gm0.*k_b(1); Cbej0=ImHQ-Cbei0;
fn=num_bias-7;
Cbej0(fn:num_bias)=Cbej0(fn:num_bias).*0+Cbej0(fn-1);
Cbei0=ImHQ-Cbej0;
%plot(gm0,Cbei0,gm0,Cbej0);
k_b=linefit(Cbei0(1:10),ReHQ(1:10),1,6,1,1,'ks','k');
Tautr0=Cbei0./gm0;
Taud0=k_b(2)/Cbej0(8)/Tautr0(1).*Tautr0;
Tauin0=(Taud0(1)-k_b(1))/Tautr0(1).*Tautr0;
%plot(gm0,Tautr0,gm0,Tauin0,gm0,Taud0);

%==== extract rbi =====
gbe=Ib_tmp./0.026;
for step=1:1:num_bias
    Y=Y_cell_exp{step}(:,2:5);
    Y11=gbe(step)+j.*Omega*(Cbej0(step)+Cbci(step))...
        +j.*Omega.*Cbei0(step)./(1+j.*Omega.*Tauin0(step));
    Ybi=1./(1./Y(:,1)-1./Y11);

    Rbi(step)=sum(1./real(Ybi(11:15)))/(15-11+1);

```

```

% subplot(1,2,1);
% plot(Omega,1./real(Ybi),Omega,Omega+Rbi(step)-Omega); hold on;
% subplot(1,2,2);
% plot(Omega,imag(Ybi)./Omega,Omega,Omega.*0+(Cbei0(step))/5);
end

Rci=Rbi-Rbi; % set to be zero

%=== If rbi bias dependent method, use the following block
%Tau_in=Tauin0; Rd=Tau_in./Cbei;
%Tau_out_all=Taud0;
%Taud=Tau_out_all-Tau_in;
%Cbei=Cbei0;
%gm=gm0;
%Cbej=Cbej0;
% ===== over =====

%=== If rbi bias independent, cnt =====
%=== de Rbi Cbi, Rci =====
for step=1:1:num_bias
    rbi(step)=Ri; % bias independent value
    Y=Y_cell_exp{step}(:,2:5);
    if(HasCbi==1)
        Cbi(step)=(Cbci(step)+Cbet_QS(step))./5;
        Zrbi=Rbi(step)./(1+j.*Omega.*Rbi(step).*Cbi(step));
    else
        Zrbi=Omega-Omega+Rbi(step);
    end;
    Y=com_Y_rb(Y,-Zrbi);
    Y=com_Y_rc(Y,-Rci(step));
    Y_cell_exp_sav{step}(:,2:5)=Y;
end;

%=== Extracion of the intrinsic transistor
% for bias independent rbi method =====

for step=1:1:num_bias
    ytmp=Y_cell_exp_sav{step}(:,2:5);

    %--- Cbci
    ben=1; enn=6;
    k_b=polyfit(Omega(ben:enn).^2,imag(ytmp(ben:enn,2))./Omega(ben:enn),1);
    %plot(Omega.^2,imag(ytmp(:,2))./Omega,Omega.^2,Omega.^2*k_b(1)+k_b(2));
    %Cbci(step)=-k_b(2);

    %--- ru
    ben=1; enn=4;
    k_b=polyfit(Omega(ben:enn).^2,real(ytmp(ben:enn,2)),1);
    Ru(step)=abs(1./k_b(2));
    Ru(step)=1.5e6;
    %plot(Omega.^2,real(ytmp(:,2)),Omega.^2,Omega.^2*k_b(1)+k_b(2));

    %=== de Cbci (Y12)===
    ytmp=ytmp-[-ytmp(:,2) ytmp(:,2) ytmp(:,2) -ytmp(:,2)];
    Y_cell_exp{step}(:,2:5)=ytmp;

```

```

%plot(Omega,real(ytmp(:,1))); hold on;

%--- gbe
ben=1; enn=5;
k_b=polyfit(Omega(ben:enn).^2,real(ytmp(ben:enn,1)),1);
%plot(Omega.^2,real(ytmp(:,1)),Omega.^2,Omega.^2*k_b(1)+k_b(2));
gbe_ex(step)=k_b(2);

%--- Cd*Cd*Rd
ben=1; enn=15;
k_b=polyfit(Omega(ben:enn).^2,real(ytmp(ben:enn,1)),1);
%plot(Omega,real(ytmp(:,1)),Omega,Omega.^2*k_b(1)+k_b(2)); hold on;
CdCdRd(step)=k_b(1);

%--- Cbet
ben=1; enn=6;
k_b=polyfit(Omega(ben:enn).^2,imag(ytmp(ben:enn,1))./Omega(ben:enn),1);
%plot(Omega.^2,imag(ytmp(:,1))./Omega,Omega.^2,Omega.^2*k_b(1)+k_b(2));
Cbet(step)=k_b(2);
CdCdCdRdRd(step)=-k_b(1);

%--- gm
ben=1; enn=6;
k_b=polyfit(Omega(ben:enn).^2,real(ytmp(ben:enn,3)),1);
%plot(Omega.^2,real(ytmp(:,3)),Omega.^2,Omega.^2*k_b(1)+k_b(2));
gm_ex(step)=k_b(2);

%--- Taud+Tau_in = Tau_out_all
ben=10; enn=20;
k_b=polyfit(Omega(ben:enn).^2,imag(ytmp(ben:enn,3))./Omega(ben:enn),1);
%plot(Omega.^2,imag(ytmp(:,3))./Omega,Omega.^2,Omega.^2*k_b(1)+k_b(2));
Tau_out_all(step)=-k_b(2)/gm_ex(step);

gm(step)=gm_ex(step);
%gbe(step)=gbe_ex(step);
gbe(step)=Ib_tmp(step)./(k*bias_cell{step}(5)/q);%gbe_ex(step);
end;

%=== split Cbet into Cbei and Cbej
k_b=polyfit(gm(1:10),Cbet(1:10),1);
%plot(gm,Cbet,gm,gm*k_b(1)+k_b(2));
for step=1:1:num_bias;
    Cbej(step)=k_b(2);
    Cbei(step)=Cbet(step)-Cbej(step);
    Tau_in(step)=CdCdRd(step)/Cbei(step);
end;
Tau_in(1)=Tau_in(3);
Tau_in(2)=Tau_in(3);
Rd=Tau_in./Cbei;
Taud_old=Tau_out_all-Tau_in;
Taud=fitcurv(Taud_old',1)';

%plot(Vbe(1:num_bias),Tau_in,'r*',Vbe(1:num_bias),Tau_out_all,'rs',...
%      Vbe(1:num_bias),Taud_QS,'gv',Vbe(1:num_bias),Cbei./gm); hold on;

```

APPENDIX F

MATLAB CODE FOR INTRINSIC NOISE EXTRACTION

The following MATLAB code is used to extract the intrinsic noise for a 50 GHz SiGe HBT with $A_E = 0.24 \times 20 \times 2 \mu\text{m}^2$. `N_exp_adm_cell_intr` is the full PSD of intrinsic base and collector current noises. `N_exp_adm_cell_base` is the PSD of base electron noise, i.e. the $2qI_b$ removed version of `N_exp_adm_cell_intr`.

F.1 MATLAB code

```
load_data_26G;
num_b=1;
num_e=20;
Omega=Y_cell_exp{step}(:,1).*2.*pi;

index=[1 4 9 14 19 24]; %Noise frequency points

for step=num_b:1:num_e
    %de-embedded Y parameters
    N_Y_exp=select_row(Y_cell_exp{step},index);
    f_N=N_Y_exp(:,1);
    Omega_N=f_N*2*pi;
    N_Y_6=N_Y_exp(:,2:5);

    N_Y_5=com_Y_rc(N_Y_6,-j*Omega_N*Lc(step)-Rcx(step)); %Lc Rcx
    N_Y_5=com_Y_rb(N_Y_5,-j*Omega_N*Lb(step)); %Lb
    N_Y_5=com_Y_re(N_Y_5,-j*Omega_N*Le(step)); %Le

    N_Y_4=N_Y_5;
    N_Y_4(:,4)=N_Y_4(:,4)...
    -j*Omega_N.*Ccs(step)./(1+j*Omega_N*Ccs(step)*Rcs(step));%Rcs Ccs
    N_Y_4=N_Y_4-[j*Omega_N*Cbco(step) ...
    -j*Omega_N*Cbco(step) ...
    -j*Omega_N*Cbco(step) ...
    j*Omega_N*Cbco(step)]; %Cbco

    N_Y_3=com_Y_rb(N_Y_4,-Rbx(step)); %Rbx
    N_Y_3=com_Y_rc(N_Y_3,-Rci(step)); %Rci
    N_Y_3=com_Y_re(N_Y_3,-Re(step)); %Re
    N_Y_2=N_Y_3;

    N_Y_2(:,1)=N_Y_2(:,1)-j*Omega_N*Cbex(step)-gbex(step); %Cbex
```

```

N_Y_2=N_Y_2-[j*Omega_N*Cbcx(step) ...
            -j*Omega_N*Cbcx(step) ...
            -j*Omega_N*Cbcx(step) ...
            j*Omega_N*Cbcx(step)]; %Cbcx

if(HasCbi==1)
    Zrbi=Rbi(step)/(1+j.*Omega_N.*Rbi(step).*Cbi(step));
else
    Zrbi=Rbi(step);
end;
N_Yintrinsic=com_Y_rb(N_Y_2,-Zrbi); %Rbi Cbi

N_Ybase=N_Yintrinsic;
N_Ybase(:,1)=N_Ybase(:,1)-gbe(step)-j*Omega_N*Cbej(step);

N_Yintr_cell_exp{step}=[f_N N_Yintrinsic];
N_Ybase_cell_exp{step}=[f_N N_Ybase];

%Noise de-embedding
T=bias_cell{step}(5);
N_exp_6=FRY_to_Svi(10.^(N_cell_exp{step}(:,2)/10),...
    N_cell_exp{step}(:,3)*get_Z0,N_cell_exp{step}(:,4),T_noise);

N_exp_5=cha_to_imp_noise(N_exp_6,Y_to_Z(N_Y_6));
N_exp_5(:,4)=N_exp_5(:,4)-4*k*T*Rcx(step); %Rcx

N_exp_4=imp_to_adm_noise(N_exp_5,N_Y_5);
N_exp_4(:,4)=N_exp_4(:,4)-...
4*k*T*real(j*Omega_N.*Ccs(step)/(1+j*Omega_N.*Ccs(step)*Rcs(step)));%Rcs

N_exp_3=adm_to_imp_noise(N_exp_4,Y_to_Z(N_Y_4));
N_exp_3(:,1)=N_exp_3(:,1)-4*k*T*(Re(step)+Rbx(step)); % Rbx re
N_exp_3(:,4)=N_exp_3(:,4)-4*k*T*(Re(step)+Rci(step)); % Rci re
N_exp_3(:,2)=N_exp_3(:,2)-4*k*T*(Re(step)); %re
N_exp_3(:,3)=N_exp_3(:,3)-4*k*T*(Re(step)); %re

N_exp_2=imp_to_adm_noise(N_exp_3,N_Y_3);
N_exp_2(:,1)=N_exp_2(:,1)-2.*k.*T.*gbex(step); %gbex
N_exp_1=adm_to_imp_noise(N_exp_2,Y_to_Z(N_Y_2));
if(HasCbi==1)
    Zrbi=Rbi(step)/(1+j.*Omega_N.*Rbi(step).*Cbi(step));
else
    Zrbi=Rbi(step);
end;
if(HasCrowdingnoise==1)
    noiserbiv=(4.*k.*T./Rbi(step)-2.*q.*Ib_tmp(step)/3).*Zrbi.*conj(Zrbi);
else
    noiserbiv=4.*k.*T./Rbi(step).*Zrbi.*conj(Zrbi);
end;
N_exp_1(:,1)=N_exp_1(:,1)-noiserbiv; %Rbi

N_exp_intrinsic=imp_to_adm_noise(N_exp_1,N_Yintrinsic);

N_exp_base=N_exp_intrinsic;
N_exp_base(:,1)=N_exp_base(:,1)-2*q*Ib_tmp(step);

N_exp_adm_cell{step}=[f_N N_exp_intrinsic]; % for noise calculateion

```

```

N_exp_adm_cell_intr{step}=[f_N N_exp_intrinsic]; % intrinsic
N_exp_adm_cell_base{step}=[f_N N_exp_base]; % base

end;

```

F.2 Data of S-parameters and noise

The following is the S-parameters and noise data de-embedded with OPEN structure for the 50 GHz SiGe HBT with $A_E = 0.24 \times 20 \times 2 \mu\text{m}^2$.

```

!
! S-Parameters vs Frequency vs Bias
!M NOISE: M:PS;A:16;C:16;DC:1;H:0;P:1;DOT:DUT_NF_M;
!
! Bias# 1
! Bias Values Read:
! Vb:.770 V, Ib:.002 mA
! Vc:1.500 V, Ic:.520 mA
! Date: 27 Mar 2003
! Time: 15:52:30
! Deembedding: ON
!
!
! Freq      S11 Mag   S11 Ang   S21 Mag   S21 Ang   S12 Mag   S12 Ang   S22 Mag   S22 Ang
! (GHz)      (Deg)      (Deg)      (Deg)      (Deg)      (Deg)      (Deg)      (Deg)      (Deg)
!-----
! 2.0000    .978      -24.1     1.921     160.8     .051      74.7      .978      -7.7
! 3.0000    .957      -35.8     1.755     152.0     .075      67.5      .959      -10.9
! 4.0000    .935      -46.7     1.724     143.6     .095      60.9      .937      -13.8
! 5.0000    .919      -56.8     1.630     136.2     .113      54.9      .914      -16.6
! 6.0000    .897      -66.4     1.457     128.2     .129      49.4      .896      -18.5
! 7.0000    .878      -75.0     1.472     122.3     .141      44.0      .869      -21.3
! 8.0000    .858      -83.4     1.403     115.8     .151      39.3      .848      -23.3
! 9.0000    .843      -90.4     1.312     110.1     .161      35.2      .831      -25.0
! 10.0000   .826      -97.5     1.233     104.7     .167      31.3      .814      -26.7
! 11.0000   .820     -102.1    1.200     99.8      .177      28.2      .794      -28.5
! 12.0000   .797     -109.1    1.110     94.8      .179      24.7      .783      -29.8
! 13.0000   .790     -114.9    1.047     90.0      .182      21.5      .770      -31.2
! 14.0000   .780     -119.2    1.000     85.6      .186      18.6      .758      -32.7
! 15.0000   .770     -124.1    .938      81.7      .187      16.1      .750      -34.1
! 16.0000   .760     -127.8    .931      77.8      .190      13.6      .733      -35.7
! 17.0000   .751     -131.9    .876      74.2      .191      11.6      .725      -37.0
! 18.0000   .749     -135.7    .834      70.6      .193      9.2       .718      -38.4
! 19.0000   .739     -137.6    .815      67.8      .195      7.4       .706      -40.1
! 20.0000   .741     -141.7    .787      64.1      .195      4.8       .698      -41.3
! 21.0000   .737     -145.4    .750      61.0      .188      2.8       .693      -42.6
! 22.0000   .734     -147.3    .724      57.6      .192      .5        .686      -43.8
! 23.0000   .722     -150.4    .697      55.4      .189      .1        .678      -45.6
! 24.0000   .723     -152.8    .668      52.1      .191     -2.1      .670      -46.7
! 25.0000   .721     -155.3    .644      49.8      .189     -3.5      .666      -48.6
! 26.0000   .723     -157.5    .618      47.4      .186     -5.1      .665      -49.7
!
! Noise Parameters vs Frequency vs Bias
!M NOISE: M:PS;A:16;C:16;DC:1;H:0;P:1;DOT:DUT_NF_M;
!
! Freq      F(min)    Gamma Opt  Gamma Opt  Normalized  Associated
! (GHz)      Fitted    Fitted    Fitted    Rn Z0=50   Gain (dB)
!           (dB)      Mag       Angle     Fitted     Fitted
!-----

```

2.0000	.23	.770	8.2	.66	15.57
5.0000	.66	.801	36.8	.70	9.72
10.0000	1.25	.704	77.5	.61	6.92
15.0000	2.72	.614	106.4	.56	4.47
20.0000	3.19	.600	130.1	.39	2.86
25.0000	4.30	.625	145.5	.34	.93

S-Parameters vs Frequency vs Bias
M NOISE: M:PS;A:16;C:16;DC:1;H:0;P:1;DOT:DUT_NF_M;

Bias# 2
Bias Values Read:
Vb:.796 V, Ib:.008 mA
Vc:1.500 V, Ic:1.400 mA
Date: 27 Mar 2003
Time: 15:52:32
Deembedding: ON

Freq (GHz)	S11 Mag	S11 Ang (Deg)	S21 Mag	S21 Ang (Deg)	S12 Mag	S12 Ang (Deg)	S22 Mag	S22 Ang (Deg)
2.0000	.949	-34.5	4.789	155.8	.050	69.6	.952	-12.2
3.0000	.912	-50.5	4.283	145.9	.070	60.5	.909	-16.8
4.0000	.880	-64.5	4.020	136.6	.086	52.9	.863	-20.7
5.0000	.859	-76.6	3.686	129.1	.099	46.3	.818	-24.0
6.0000	.832	-87.8	3.233	121.7	.109	40.5	.785	-25.7
7.0000	.814	-97.1	3.122	115.7	.116	35.6	.741	-28.6
8.0000	.796	-106.0	2.885	109.9	.121	31.0	.708	-30.3
9.0000	.782	-112.9	2.640	105.1	.126	27.7	.685	-31.6
10.0000	.766	-119.7	2.433	100.5	.128	24.4	.664	-32.8
11.0000	.764	-123.4	2.310	96.3	.135	22.1	.637	-34.3
12.0000	.748	-130.2	2.111	92.5	.134	19.3	.626	-35.1
13.0000	.743	-135.2	1.968	88.8	.134	16.9	.612	-36.1
14.0000	.738	-138.9	1.853	85.5	.136	14.6	.600	-37.1
15.0000	.731	-143.3	1.723	82.3	.136	12.9	.592	-38.0
16.0000	.726	-146.3	1.676	79.0	.138	10.9	.571	-39.3
17.0000	.720	-150.0	1.566	76.2	.138	9.3	.565	-40.3
18.0000	.720	-152.8	1.483	73.6	.138	7.6	.559	-41.5
19.0000	.711	-153.9	1.426	71.4	.140	6.7	.547	-42.8
20.0000	.714	-153.0	1.367	69.6	.138	4.5	.539	-43.8
21.0000	.710	-161.5	1.294	65.8	.132	3.9	.537	-44.6
22.0000	.714	-162.5	1.242	63.2	.136	1.7	.529	-45.7
23.0000	.701	-165.1	1.192	61.1	.135	1.6	.522	-47.2
24.0000	.704	-167.2	1.132	58.9	.134	.2	.516	-48.1
25.0000	.701	-168.9	1.092	56.5	.133	.1	.514	-49.8
26.0000	.705	-171.3	1.036	54.8	.131	-1.7	.514	-51.1

Noise Parameters vs Frequency vs Bias
M NOISE: M:PS;A:16;C:16;DC:1;H:0;P:1;DOT:DUT_NF_M;

Freq (GHz)	F(min) Fitted (dB)	Gamma Opt Fitted Mag	Gamma Opt Fitted Angle	Normalized Rn Z0=50 Fitted	Associated Gain (dB) Fitted
2.0000	-0.00	.905	7.2	.37	14.10
5.0000	.65	.608	33.7	.39	13.81
10.0000	1.02	.545	78.9	.32	10.06
15.0000	2.14	.476	109.7	.30	7.54
20.0000	2.56	.466	136.9	.23	5.98
25.0000	3.54	.509	151.5	.22	4.13

S-Parameters vs Frequency vs Bias
M NOISE: M:PS;A:16;C:16;DC:1;H:0;P:1;DOT:DUT_NF_M;

Bias# 3
Bias Values Read:
Vb:.811 V, Ib:.014 mA
Vc:1.500 V, Ic:2.560 mA
Date: 27 Mar 2003
Time: 15:52:35
Deembedding: ON

Freq	S11 Mag	S11 Ang	S21 Mag	S21 Ang	S12 Mag	S12 Ang	S22 Mag	S22 Ang
------	---------	---------	---------	---------	---------	---------	---------	---------

(GHz)	(Deg)	(Deg)	(Deg)	(Deg)	(Deg)	(Deg)	(Deg)	
2.0000	.914	-45.0	7.683	150.5	.048	64.7	.917	-16.9
3.0000	.869	-64.5	6.708	139.5	.064	54.2	.849	-22.6
4.0000	.836	-80.2	6.041	129.7	.076	46.3	.781	-26.9
5.0000	.815	-93.5	5.388	122.1	.085	39.7	.721	-30.1
6.0000	.791	-104.9	4.658	115.2	.091	34.4	.680	-31.4
7.0000	.776	-114.1	4.355	109.5	.096	30.0	.629	-34.0
8.0000	.763	-122.5	3.952	104.4	.098	26.2	.594	-35.2
9.0000	.754	-128.7	3.579	100.1	.101	23.4	.571	-36.0
10.0000	.743	-134.9	3.267	96.5	.101	20.9	.550	-36.8
11.0000	.742	-138.0	3.060	92.3	.107	19.1	.522	-37.9
12.0000	.732	-144.0	2.787	89.2	.105	17.1	.513	-38.4
13.0000	.731	-148.4	2.584	86.0	.105	15.3	.501	-38.9
14.0000	.728	-151.5	2.420	83.5	.106	13.4	.489	-39.7
15.0000	.723	-155.3	2.250	80.5	.105	12.3	.483	-40.4
16.0000	.716	-157.9	2.165	77.6	.106	10.8	.463	-41.6
17.0000	.714	-160.8	2.021	75.0	.106	10.1	.458	-42.2
18.0000	.714	-163.2	1.911	73.0	.106	8.9	.452	-43.3
19.0000	.709	-164.3	1.829	71.1	.108	8.1	.441	-44.3
20.0000	.712	-167.5	1.748	68.3	.106	6.8	.432	-45.2
21.0000	.713	-170.3	1.652	66.3	.101	7.2	.433	-45.8
22.0000	.710	-171.4	1.581	64.0	.104	5.2	.426	-46.7
23.0000	.701	-173.1	1.509	62.4	.104	5.3	.419	-48.2
24.0000	.702	-175.0	1.440	60.3	.103	4.5	.417	-49.1
25.0000	.708	-177.1	1.385	58.6	.103	5.6	.413	-50.5
26.0000	.709	-178.4	1.319	56.8	.100	3.5	.414	-51.8

Noise Parameters vs Frequency vs Bias
M NOISE: M:PS;A:16;C:16;DC:1;H:0;P:1;DOT:DUT_NF_M;

Freq (GHz)	F(min) Fitted (dB)	Gamma Opt Fitted Mag	Gamma Opt Fitted Angle	Normalized Rn Z0=50 Fitted	Associated Gain (dB) Fitted
2.0000	.21	.893	5.9	.29	15.54
5.0000	.65	.533	32.1	.30	15.35
10.0000	.97	.460	80.5	.25	11.51
15.0000	1.92	.407	114.1	.23	9.02
20.0000	2.33	.397	143.3	.19	7.42
25.0000	3.19	.448	157.7	.20	5.66

S-Parameters vs Frequency vs Bias
M NOISE: M:PS;A:16;C:16;DC:1;H:0;P:1;DOT:DUT_NF_M;

Bias# 4
Bias Values Read:
Vb:.819 V, Ib:.022 mA
Vc:1.500 V, Ic:3.360 mA
Date: 27 Mar 2003
Time: 15:52:37
Deembedding: ON

Freq (GHz)	S11 Mag	S11 Ang (Deg)	S21 Mag	S21 Ang (Deg)	S12 Mag	S12 Ang (Deg)	S22 Mag	S22 Ang (Deg)
2.0000	.891	-52.0	9.538	147.1	.046	61.4	.889	-20.0
3.0000	.844	-73.3	8.175	135.5	.060	50.7	.806	-26.2
4.0000	.814	-89.7	7.186	125.6	.070	42.5	.726	-30.4
5.0000	.793	-103.2	6.308	118.1	.077	36.2	.661	-33.5
6.0000	.773	-114.4	5.420	111.7	.081	31.4	.618	-34.4
7.0000	.761	-123.0	4.980	106.2	.084	27.4	.566	-36.7
8.0000	.753	-131.0	4.484	101.4	.086	24.2	.532	-37.6
9.0000	.744	-136.7	4.042	97.7	.088	21.9	.510	-38.1
10.0000	.737	-142.3	3.673	93.8	.089	19.7	.490	-38.7
11.0000	.736	-145.3	3.418	90.3	.093	18.1	.464	-39.6
12.0000	.729	-150.6	3.115	87.7	.091	16.5	.456	-39.8
13.0000	.729	-154.6	2.884	84.6	.091	15.4	.444	-40.3
14.0000	.725	-157.3	2.695	81.9	.092	13.8	.434	-40.9
15.0000	.722	-160.7	2.505	79.5	.091	13.1	.428	-41.5
16.0000	.719	-163.1	2.397	76.8	.092	11.9	.409	-42.5
17.0000	.715	-165.7	2.240	74.7	.091	11.4	.405	-43.0
18.0000	.717	-168.0	2.115	72.7	.091	10.1	.401	-44.2

19.0000	.706	-169.0	2.017	70.8	.093	9.7	.390	-45.1
20.0000	.714	-171.9	1.933	68.2	.092	8.5	.383	-45.8
21.0000	.711	-174.6	1.828	66.3	.087	9.4	.383	-46.4
22.0000	.712	-175.3	1.746	64.2	.090	7.9	.377	-47.2
23.0000	.699	-177.3	1.662	62.7	.090	9.0	.372	-48.6
24.0000	.714	-178.9	1.590	60.6	.089	7.5	.367	-49.4
25.0000	.715	-179.6	1.531	58.8	.089	8.4	.366	-50.8
26.0000	.708	-178.4	1.453	57.3	.087	7.3	.364	-51.9

Noise Parameters vs Frequency vs Bias
M NOISE: M:PS;A:16;C:16;DC:1;H:0;P:1;DOT:DUT_NF_M;

Freq (GHz)	F(min) Fitted (dB)	Gamma Opt Fitted Mag	Gamma Opt Fitted Angle	Normalized Rn Z0=50 Fitted	Associated Gain (dB) Fitted
2.0000	.25	.908	8.2	.26	15.64
5.0000	.71	.498	32.6	.27	16.11
10.0000	1.02	.419	81.8	.22	12.15
15.0000	1.85	.366	116.6	.21	9.66
20.0000	2.26	.384	147.3	.16	8.09
25.0000	3.05	.432	160.7	.18	6.35

S-Parameters vs Frequency vs Bias
M NOISE: M:PS;A:16;C:16;DC:1;H:0;P:1;DOT:DUT_NF_M;

Bias# 5
Bias Values Read:
Vb:.829 V, Ib:.028 mA
Vc:1.500 V, Ic:4.860 mA
Date: 27 Mar 2003
Time: 15:52:39
Deembedding: ON

Freq (GHz)	S11 Mag	S11 Ang (Deg)	S21 Mag	S21 Ang (Deg)	S12 Mag	S12 Ang (Deg)	S22 Mag	S22 Ang (Deg)
2.0000	.855	-63.1	12.354	141.9	.043	56.4	.840	-24.8
3.0000	.810	-86.6	10.258	129.7	.054	45.3	.734	-31.3
4.0000	.787	-103.3	8.721	119.9	.061	37.6	.644	-35.3
5.0000	.771	-116.4	7.502	112.8	.066	31.9	.576	-37.8
6.0000	.758	-126.7	6.392	107.0	.068	28.0	.533	-38.2
7.0000	.750	-134.5	5.758	102.0	.070	24.9	.484	-40.0
8.0000	.745	-141.5	5.137	97.8	.071	22.3	.453	-40.4
9.0000	.740	-146.6	4.608	94.2	.072	20.6	.432	-40.7
10.0000	.735	-151.4	4.172	90.9	.073	19.1	.415	-40.8
11.0000	.734	-154.1	3.856	87.8	.076	18.1	.391	-41.5
12.0000	.730	-158.6	3.516	85.3	.074	16.4	.384	-41.5
13.0000	.730	-161.8	3.250	82.7	.074	16.1	.375	-41.8
14.0000	.728	-164.2	3.031	80.3	.075	14.8	.365	-42.3
15.0000	.727	-167.2	2.817	78.1	.074	14.6	.359	-42.6
16.0000	.724	-169.4	2.680	75.7	.075	14.1	.343	-43.6
17.0000	.726	-171.5	2.508	73.8	.075	13.6	.340	-44.0
18.0000	.723	-173.6	2.361	71.9	.075	13.4	.336	-45.2
19.0000	.718	-174.6	2.257	70.2	.075	13.4	.328	-45.9
20.0000	.719	-176.9	2.150	67.9	.075	12.3	.320	-46.5
21.0000	.723	-179.1	2.038	66.0	.072	14.2	.321	-47.0
22.0000	.717	-179.8	1.944	64.1	.074	11.8	.316	-47.6
23.0000	.714	-178.5	1.859	62.9	.074	13.1	.310	-49.3
24.0000	.722	-177.0	1.772	60.9	.075	13.1	.305	-50.2
25.0000	.716	-175.7	1.700	59.4	.073	13.1	.304	-51.1
26.0000	.719	-174.6	1.621	57.7	.075	13.6	.304	-52.8

Noise Parameters vs Frequency vs Bias
M NOISE: M:PS;A:16;C:16;DC:1;H:0;P:1;DOT:DUT_NF_M;

Freq (GHz)	F(min) Fitted (dB)	Gamma Opt Fitted Mag	Gamma Opt Fitted Angle	Normalized Rn Z0=50 Fitted	Associated Gain (dB) Fitted
2.0000	.11	.941	11.0	.25	14.47

5.0000	.78	.450	38.8	.22	17.31
10.0000	1.07	.354	85.9	.20	13.04
15.0000	1.80	.319	122.4	.20	10.45
20.0000	2.18	.352	154.5	.16	8.83
25.0000	2.97	.414	164.8	.17	7.04

S-Parameters vs Frequency vs Bias
M NOISE: M:PS;A:16;C:16;DC:1;H:0;P:1;DOT:DUT_NF_M;

Bias# 6
Bias Values Read:
Vb:.831 V, Ib:.036 mA
Vc:1.500 V, Ic:5.060 mA
Date: 27 Mar 2003
Time: 15:52:42
Deembedding: ON

Freq (GHz)	S11 Mag	S11 Ang (Deg)	S21 Mag	S21 Ang (Deg)	S12 Mag	S12 Ang (Deg)	S22 Mag	S22 Ang (Deg)
2.0000	.844	-66.3	13.111	140.5	.042	55.1	.825	-26.1
3.0000	.802	-90.2	10.793	128.1	.052	44.0	.714	-32.7
4.0000	.781	-106.8	9.103	118.5	.059	36.4	.622	-36.5
5.0000	.767	-119.7	7.789	111.5	.063	31.1	.554	-38.9
6.0000	.755	-129.8	6.624	105.8	.065	27.1	.511	-39.2
7.0000	.748	-137.3	5.938	100.9	.067	24.2	.463	-40.7
8.0000	.744	-144.1	5.288	96.8	.067	21.9	.433	-41.1
9.0000	.739	-148.9	4.739	93.4	.069	20.3	.413	-41.1
10.0000	.735	-153.6	4.289	90.2	.069	19.2	.397	-41.2
11.0000	.735	-156.3	3.958	87.1	.072	18.1	.374	-41.9
12.0000	.729	-160.5	3.606	84.7	.070	17.1	.367	-41.9
13.0000	.732	-163.6	3.337	82.2	.070	16.4	.358	-42.1
14.0000	.728	-165.9	3.108	79.9	.071	15.6	.349	-42.6
15.0000	.730	-168.7	2.891	77.7	.070	15.1	.343	-43.0
16.0000	.725	-170.7	2.745	75.4	.071	15.1	.328	-43.8
17.0000	.725	-173.0	2.564	73.5	.071	14.5	.325	-44.3
18.0000	.725	-174.8	2.421	71.7	.071	14.1	.322	-45.4
19.0000	.722	-176.0	2.311	70.0	.072	13.9	.313	-46.1
20.0000	.722	-178.1	2.198	67.8	.072	13.8	.305	-46.9
21.0000	.723	180.0	2.087	66.0	.068	14.4	.307	-47.4
22.0000	.718	178.8	1.991	64.1	.071	13.7	.302	-47.9
23.0000	.711	177.6	1.899	62.9	.070	15.1	.296	-49.3
24.0000	.720	176.1	1.809	61.0	.071	14.3	.292	-50.0
25.0000	.721	175.0	1.744	59.4	.071	16.2	.291	-51.5
26.0000	.719	173.8	1.662	57.9	.071	15.7	.287	-52.6

Noise Parameters vs Frequency vs Bias
M NOISE: M:PS;A:16;C:16;DC:1;H:0;P:1;DOT:DUT_NF_M;

Freq (GHz)	F(min) Fitted (dB)	Gamma Opt Fitted Mag	Gamma Opt Fitted Angle	Normalized Rn Z0=50 Fitted	Associated Gain (dB) Fitted
2.0000	.27	.845	15.6	.24	19.41
5.0000	.89	.386	29.1	.24	17.42
10.0000	1.08	.338	87.0	.19	13.24
15.0000	1.79	.312	123.9	.19	10.63
20.0000	2.17	.347	156.5	.16	9.00
25.0000	2.95	.417	165.2	.16	7.26

S-Parameters vs Frequency vs Bias
M NOISE: M:PS;A:16;C:16;DC:1;H:0;P:1;DOT:DUT_NF_M;

Bias# 7
Bias Values Read:
Vb:.836 V, Ib:.042 mA
Vc:1.500 V, Ic:6.180 mA
Date: 27 Mar 2003
Time: 15:52:44
Deembedding: ON

Freq	S11 Mag	S11 Ang	S21 Mag	S21 Ang	S12 Mag	S12 Ang	S22 Mag	S22 Ang
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(GHz)	(Deg)	(Deg)	(Deg)	(Deg)	(Deg)	(Deg)		
2.0000	.825	-72.9	14.618	137.6	.040	52.4	.793	-28.8
3.0000	.787	-97.4	11.808	125.1	.049	41.4	.673	-35.3
4.0000	.771	-113.7	9.801	115.7	.054	34.1	.579	-38.8
5.0000	.760	-126.0	8.305	109.0	.057	29.3	.512	-40.8
6.0000	.751	-135.5	7.044	103.7	.059	26.0	.470	-40.8
7.0000	.745	-142.5	6.261	99.0	.060	23.4	.425	-42.0
8.0000	.743	-148.7	5.559	95.2	.060	21.5	.397	-42.2
9.0000	.740	-153.2	4.976	92.0	.062	20.4	.379	-42.0
10.0000	.735	-157.5	4.496	88.9	.062	19.3	.363	-42.1
11.0000	.737	-160.1	4.137	86.0	.064	18.6	.342	-42.6
12.0000	.734	-163.9	3.775	83.8	.063	18.1	.337	-42.5
13.0000	.735	-166.6	3.486	81.4	.063	17.5	.328	-42.7
14.0000	.731	-168.8	3.247	79.1	.063	16.8	.320	-43.1
15.0000	.731	-171.3	3.023	77.1	.063	17.1	.314	-43.5
16.0000	.729	-173.3	2.862	74.8	.064	16.6	.300	-44.2
17.0000	.728	-175.3	2.677	73.1	.064	16.3	.296	-44.5
18.0000	.729	-177.2	2.523	71.3	.064	16.6	.293	-45.8
19.0000	.725	-178.2	2.408	69.6	.064	16.7	.286	-46.3
20.0000	.725	-179.7	2.292	67.6	.065	16.4	.278	-47.2
21.0000	.733	-177.3	2.174	65.7	.062	17.7	.279	-47.6
22.0000	.726	-177.1	2.069	63.9	.064	16.6	.275	-47.9
23.0000	.719	-175.7	1.980	62.6	.063	17.7	.271	-49.6
24.0000	.723	-174.1	1.889	61.0	.065	17.6	.266	-50.3
25.0000	.724	-172.9	1.803	59.5	.064	19.2	.266	-51.7
26.0000	.723	-172.1	1.728	58.0	.065	18.4	.262	-53.0

Noise Parameters vs Frequency vs Bias
M NOISE: M:PS;A:16;C:16;DC:1;H:0;P:1;DOT:DUT_NF_M;

Freq (GHz)	F(min) Fitted (dB)	Gamma Opt Fitted Mag	Gamma Opt Fitted Angle	Normalized Rn Z0=50 Fitted	Associated Gain (dB) Fitted
2.0000	.50	.649	17.4	.23	23.42
5.0000	.84	.390	42.0	.21	18.13
10.0000	1.16	.319	89.9	.18	13.599
15.0000	1.80	.299	127.7	.18	10.998
20.0000	2.15	.337	161.1	.16	9.33
25.0000	3.03	.406	169.3	.16	7.52

S-Parameters vs Frequency vs Bias
M NOISE: M:PS;A:16;C:16;DC:1;H:0;P:1;DOT:DUT_NF_M;

Bias# 8
Bias Values Read:
Vb:.841 V, Ib:.050 mA
Vc:1.500 V, Ic:7.380 mA
Date: 27 Mar 2003
Time: 15:52:47
Deembedding: ON

Freq (GHz)	S11 Mag	S11 Ang (Deg)	S21 Mag	S21 Ang (Deg)	S12 Mag	S12 Ang (Deg)	S22 Mag	S22 Ang (Deg)
2.0000	.805	-80.0	16.115	134.5	.038	49.8	.757	-31.5
3.0000	.775	-104.6	12.772	122.0	.045	39.0	.630	-37.8
4.0000	.763	-120.4	10.449	113.0	.049	32.3	.536	-40.8
5.0000	.755	-132.1	8.774	106.7	.052	27.8	.471	-42.5
6.0000	.748	-140.9	7.425	101.6	.053	25.0	.431	-42.3
7.0000	.745	-147.4	6.552	97.3	.054	23.0	.390	-43.1
8.0000	.743	-153.1	5.802	93.7	.054	21.6	.363	-43.1
9.0000	.740	-157.1	5.185	90.6	.055	20.4	.347	-42.8
10.0000	.738	-161.0	4.680	87.7	.056	19.9	.332	-42.7
11.0000	.739	-163.5	4.293	85.0	.057	19.2	.313	-43.1
12.0000	.735	-166.9	3.917	82.8	.057	19.0	.308	-43.0
13.0000	.739	-169.5	3.620	80.6	.057	18.7	.299	-43.1
14.0000	.735	-171.5	3.368	78.5	.057	18.3	.292	-43.3
15.0000	.735	-173.9	3.137	76.5	.057	18.7	.287	-43.7
16.0000	.732	-175.8	2.963	74.4	.058	18.4	.273	-44.6
17.0000	.730	-177.7	2.773	72.6	.058	19.4	.271	-44.6
18.0000	.733	-179.1	2.615	70.9	.058	19.3	.269	-45.8

19.0000	.729	179.8	2.493	69.4	.059	19.2	.261	-46.8
20.0000	.730	177.9	2.367	67.3	.059	19.4	.253	-47.4
21.0000	.732	175.6	2.252	65.6	.057	20.3	.255	-48.1
22.0000	.728	175.4	2.145	63.7	.059	19.7	.252	-48.2
23.0000	.725	173.5	2.046	62.6	.058	22.2	.247	-49.2
24.0000	.725	172.7	1.950	60.7	.060	22.2	.243	-50.7
25.0000	.729	171.6	1.877	59.7	.060	23.4	.242	-52.0
26.0000	.728	170.7	1.796	58.2	.059	24.0	.240	-53.7

Noise Parameters vs Frequency vs Bias
M NOISE: M:PS;A:16;C:16;DC:1;H:0;P:1;DOT:DUT_NF_M;

Freq (GHz)	F(min) Fitted (dB)	Gamma Opt Fitted Mag	Gamma Opt Fitted Angle	Normalized Rn Z0=50 Fitted	Associated Gain (dB) Fitted
2.0000	.66	.529	19.5	.23	25.02
5.0000	1.00	.298	31.2	.23	18.48
10.0000	1.23	.294	94.4	.18	13.97
15.0000	1.85	.296	132.2	.17	11.31
20.0000	2.21	.331	165.0	.16	9.59
25.0000	3.01	.406	171.9	.16	7.88

S-Parameters vs Frequency vs Bias
M NOISE: M:PS;A:16;C:16;DC:1;H:0;P:1;DOT:DUT_NF_M;

Bias# 9
Bias Values Read:
Vb:.844 V, Ib:.054 mA
Vc:1.500 V, Ic:8.100 mA
Date: 27 Mar 2003
Time: 15:52:49
Deembedding: ON

Freq (GHz)	S11 Mag	S11 Ang (Deg)	S21 Mag	S21 Ang (Deg)	S12 Mag	S12 Ang (Deg)	S22 Mag	S22 Ang (Deg)
2.0000	.795	-83.7	16.853	133.0	.036	48.4	.739	-32.9
3.0000	.769	-103.3	13.226	120.5	.043	37.8	.608	-39.1
4.0000	.759	-123.7	10.747	111.7	.047	31.2	.515	-41.8
5.0000	.753	-135.0	8.983	105.5	.049	27.4	.451	-43.3
6.0000	.747	-143.5	7.597	100.6	.050	24.7	.412	-42.9
7.0000	.744	-149.8	6.679	96.4	.051	22.6	.372	-43.6
8.0000	.743	-155.1	5.908	92.9	.051	21.6	.348	-43.5
9.0000	.742	-159.1	5.277	89.9	.052	20.8	.331	-43.0
10.0000	.738	-162.8	4.766	87.1	.053	20.1	.318	-42.9
11.0000	.741	-165.1	4.362	84.4	.054	19.9	.299	-43.2
12.0000	.736	-168.5	3.984	82.3	.054	19.8	.294	-43.1
13.0000	.740	-170.9	3.678	80.1	.054	19.9	.285	-43.2
14.0000	.738	-172.9	3.422	78.0	.055	19.4	.279	-43.5
15.0000	.738	-175.2	3.185	76.1	.054	19.8	.274	-43.7
16.0000	.734	-177.0	3.007	74.0	.055	19.4	.262	-44.7
17.0000	.733	-178.8	2.815	72.3	.055	20.0	.259	-44.9
18.0000	.734	-179.8	2.658	70.6	.055	20.6	.256	-46.1
19.0000	.730	-178.6	2.530	69.1	.056	21.2	.250	-47.0
20.0000	.731	-177.0	2.405	67.7	.056	21.0	.244	-47.6
21.0000	.734	-174.9	2.288	65.5	.054	23.4	.245	-48.0
22.0000	.733	-174.5	2.173	63.8	.055	21.2	.241	-48.6
23.0000	.725	-172.2	2.078	62.3	.056	22.3	.235	-49.8
24.0000	.726	-172.0	1.985	60.7	.057	23.6	.233	-50.9
25.0000	.737	-170.6	1.908	59.0	.057	24.8	.229	-52.5
26.0000	.727	-169.9	1.827	58.1	.058	25.0	.227	-53.0

Noise Parameters vs Frequency vs Bias
M NOISE: M:PS;A:16;C:16;DC:1;H:0;P:1;DOT:DUT_NF_M;

Freq (GHz)	F(min) Fitted (dB)	Gamma Opt Fitted Mag	Gamma Opt Fitted Angle	Normalized Rn Z0=50 Fitted	Associated Gain (dB) Fitted
2.0000	.72	.486	21.1	.22	25.56

5.0000	1.02	.277	32.6	.22	18.73
10.0000	1.26	.280	97.3	.17	14.17
15.0000	1.88	.291	135.6	.17	11.48
20.0000	2.23	.330	166.5	.16	9.71
25.0000	2.98	.414	174.1	.15	8.10

S-Parameters vs Frequency vs Bias
M NOISE: M:PS;A:16;C:16;DC:1;H:0;P:1;DOT:DUT_NF_M;

Bias# 10
Bias Values Read:
Vb:.849 V, Ib:.066 mA
Vc:1.500 V, Ic:9.680 mA
Date: 27 Mar 2003
Time: 15:52:52
Deembedding: ON

Freq (GHz)	S11 Mag	S11 Ang (Deg)	S21 Mag	S21 Ang (Deg)	S12 Mag	S12 Ang (Deg)	S22 Mag	S22 Ang (Deg)
2.0000	.778	-91.2	18.241	129.9	.034	45.6	.699	-35.5
3.0000	.759	-115.4	14.048	117.6	.040	35.6	.566	-41.3
4.0000	.754	-130.0	11.269	109.2	.042	29.6	.474	-43.5
5.0000	.750	-140.5	9.351	103.4	.044	26.3	.414	-44.5
6.0000	.747	-148.3	7.898	98.8	.045	24.2	.377	-43.9
7.0000	.745	-154.0	6.901	94.8	.046	22.8	.341	-44.2
8.0000	.745	-158.9	6.093	91.5	.046	21.8	.319	-44.0
9.0000	.744	-162.4	5.438	88.7	.047	21.5	.304	-43.4
10.0000	.741	-165.9	4.906	86.0	.047	21.4	.291	-43.2
11.0000	.744	-168.1	4.480	83.5	.049	21.9	.274	-43.4
12.0000	.740	-171.0	4.099	81.5	.048	21.2	.270	-43.3
13.0000	.742	-173.2	3.783	79.9	.048	21.8	.263	-43.4
14.0000	.740	-175.1	3.513	77.5	.049	21.7	.256	-43.5
15.0000	.741	-177.1	3.272	75.6	.049	22.2	.252	-43.9
16.0000	.740	-179.0	3.081	73.6	.050	22.6	.240	-44.7
17.0000	.738	-179.5	2.890	72.0	.050	23.2	.238	-44.9
18.0000	.738	-178.1	2.726	70.4	.050	23.6	.236	-46.3
19.0000	.735	-176.8	2.594	68.8	.051	24.2	.228	-46.8
20.0000	.736	-175.4	2.461	66.9	.052	23.9	.223	-47.6
21.0000	.729	-173.6	2.332	65.5	.050	24.9	.226	-48.1
22.0000	.733	-173.0	2.239	63.5	.051	24.4	.221	-48.1
23.0000	.730	-171.3	2.136	62.4	.052	27.5	.216	-49.5
24.0000	.735	-170.5	2.029	60.9	.054	27.2	.211	-50.5
25.0000	.731	-169.5	1.962	59.1	.056	30.3	.213	-52.9
26.0000	.736	-168.5	1.866	58.0	.055	29.5	.209	-53.3

Noise Parameters vs Frequency vs Bias
M NOISE: M:PS;A:16;C:16;DC:1;H:0;P:1;DOT:DUT_NF_M;

Freq (GHz)	F(min) Fitted (dB)	Gamma Opt Fitted Mag	Gamma Opt Fitted Angle	Normalized Rn Z0=50 Fitted	Associated Gain (dB) Fitted
2.0000	.84	.411	25.4	.22	26.47
5.0000	1.01	.259	43.3	.21	19.24
10.0000	1.33	.258	104.1	.17	14.52
15.0000	1.94	.287	140.3	.17	11.75
20.0000	2.29	.335	170.4	.16	9.95
25.0000	3.06	.401	176.4	.16	8.25

S-Parameters vs Frequency vs Bias
M NOISE: M:PS;A:16;C:16;DC:1;H:0;P:1;DOT:DUT_NF_M;

Bias# 11
Bias Values Read:
Vb:.851 V, Ib:.074 mA
Vc:1.500 V, Ic:10.620 mA
Date: 27 Mar 2003
Time: 15:52:54
Deembedding: ON

Freq	S11 Mag	S11 Ang	S21 Mag	S21 Ang	S12 Mag	S12 Ang	S22 Mag	S22 Ang
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(GHz)	(Deg)	(Deg)	(Deg)	(Deg)	(Deg)	(Deg)		
2.0000	.770	-95.1	18.885	128.3	.033	44.3	.679	-36.8
3.0000	.755	-118.9	14.414	116.2	.038	34.7	.545	-42.3
4.0000	.752	-133.0	11.499	108.0	.040	29.0	.455	-44.2
5.0000	.751	-143.2	9.509	102.3	.042	25.9	.396	-45.0
6.0000	.748	-150.5	8.027	97.9	.043	24.1	.361	-44.3
7.0000	.746	-155.9	6.993	94.0	.043	23.0	.327	-44.5
8.0000	.746	-160.7	6.170	90.9	.043	22.4	.306	-44.1
9.0000	.746	-164.1	5.501	88.1	.044	21.9	.292	-43.4
10.0000	.743	-167.4	4.966	85.5	.045	22.1	.279	-43.1
11.0000	.745	-169.4	4.529	83.0	.046	21.9	.263	-43.4
12.0000	.743	-172.4	4.146	81.1	.046	22.0	.259	-43.4
13.0000	.746	-174.3	3.822	79.0	.046	22.2	.252	-43.1
14.0000	.742	-176.4	3.554	77.0	.047	22.5	.246	-43.7
15.0000	.743	-178.2	3.314	75.2	.047	23.6	.241	-43.8
16.0000	.741	-180.0	3.111	73.3	.047	23.7	.231	-44.8
17.0000	.740	-178.3	2.917	71.6	.048	24.5	.228	-44.9
18.0000	.742	-177.1	2.753	70.1	.049	25.0	.227	-46.2
19.0000	.740	-175.7	2.619	68.4	.050	26.1	.220	-47.2
20.0000	.739	-174.7	2.481	66.7	.049	25.4	.216	-47.7
21.0000	.736	-172.5	2.362	65.0	.050	28.0	.216	-48.2
22.0000	.739	-172.3	2.251	63.4	.050	27.8	.212	-48.0
23.0000	.730	-170.3	2.148	62.2	.050	28.1	.207	-49.8
24.0000	.736	-169.8	2.047	60.6	.051	29.0	.203	-50.3
25.0000	.731	-168.5	1.969	59.4	.052	31.0	.202	-51.9
26.0000	.741	-167.6	1.893	57.8	.052	30.5	.199	-53.2

Noise Parameters vs Frequency vs Bias
M NOISE: M:PS;A:16;C:16;DC:1;H:0;P:1;DOT:DUT_NF_M;

Freq (GHz)	F(min) Fitted (dB)	Gamma Opt Fitted Mag	Gamma Opt Fitted Angle	Normalized Rn Z0=50 Fitted	Associated Gain (dB) Fitted
2.0000	.90	.376	27.4	.21	26.83
5.0000	1.05	.233	46.2	.20	19.49
10.0000	1.36	.246	107.9	.17	14.68
15.0000	1.96	.287	143.4	.16	11.90
20.0000	2.34	.341	172.2	.15	10.07
25.0000	3.14	.402	178.4	.17	8.28

S-Parameters vs Frequency vs Bias
M NOISE: M:PS;A:16;C:16;DC:1;H:0;P:1;DOT:DUT_NF_M;

Bias# 12
Bias Values Read:
Vb:.854 V, Ib:.082 mA
Vc:1.500 V, Ic:11.580 mA
Date: 27 Mar 2003
Time: 15:52:57
Deembedding: ON

Freq (GHz)	S11 Mag	S11 Ang (Deg)	S21 Mag	S21 Ang (Deg)	S12 Mag	S12 Ang (Deg)	S22 Mag	S22 Ang (Deg)
2.0000	.763	-98.7	19.462	126.8	.032	42.9	.659	-38.0
3.0000	.752	-122.1	14.733	114.9	.036	33.5	.524	-43.2
4.0000	.751	-135.8	11.686	107.0	.038	28.6	.437	-44.8
5.0000	.750	-145.4	9.640	101.5	.040	25.7	.381	-45.4
6.0000	.748	-152.5	8.132	97.2	.041	24.1	.346	-44.5
7.0000	.747	-157.7	7.066	93.4	.041	23.2	.314	-44.6
8.0000	.747	-162.1	6.229	90.3	.041	22.7	.294	-44.1
9.0000	.747	-165.4	5.555	87.7	.042	22.5	.280	-43.4
10.0000	.744	-168.6	5.011	85.1	.043	22.7	.269	-43.1
11.0000	.747	-170.6	4.565	82.6	.044	22.8	.254	-43.3
12.0000	.745	-173.3	4.180	80.8	.044	22.9	.250	-43.2
13.0000	.748	-175.3	3.857	78.7	.044	23.3	.242	-43.3
14.0000	.744	-177.1	3.584	76.8	.045	23.9	.237	-43.6
15.0000	.745	-178.9	3.343	75.1	.045	24.7	.232	-43.7
16.0000	.743	-179.3	3.135	73.1	.045	25.1	.222	-44.8
17.0000	.742	-177.7	2.939	71.5	.046	26.3	.220	-44.8
18.0000	.745	-176.5	2.774	70.0	.047	25.9	.218	-46.1

19.0000	.739	175.2	2.634	68.6	.047	28.1	.213	-46.7
20.0000	.740	174.0	2.498	66.7	.048	27.7	.207	-47.6
21.0000	.742	172.1	2.382	65.2	.048	30.4	.209	-47.9
22.0000	.737	171.6	2.273	63.3	.048	29.4	.204	-47.8
23.0000	.734	170.2	2.175	62.2	.048	31.9	.201	-49.4
24.0000	.734	169.4	2.072	60.7	.050	31.9	.196	-50.7
25.0000	.729	167.7	1.971	59.6	.052	31.8	.195	-51.8
26.0000	.739	167.4	1.906	57.7	.051	33.8	.192	-53.9

Noise Parameters vs Frequency vs Bias
M NOISE: M:PS;A:16;C:16;DC:1;H:0;P:1;DOT:DUT_NF_M;

Freq (GHz)	F(min) Fitted (dB)	Gamma Opt Fitted Mag	Gamma Opt Fitted Angle	Normalized Rn Z0=50 Fitted	Associated Gain (dB) Fitted
2.0000	.96	.349	29.4	.21	27.08
5.0000	1.08	.218	51.2	.20	19.72
10.0000	1.41	.242	111.5	.17	14.81
15.0000	1.99	.290	146.1	.16	12.03
20.0000	2.39	.343	173.9	.16	10.14
25.0000	3.26	.398	-179.6	.18	8.28

S-Parameters vs Frequency vs Bias
M NOISE: M:PS;A:16;C:16;DC:1;H:0;P:1;DOT:DUT_NF_M;

Bias# 13
Bias Values Read:
Vb:.856 V, Ib:.084 mA
Vc:1.500 V, Ic:12.700 mA
Date: 27 Mar 2003
Time: 15:52:59
Deembedding: ON

Freq (GHz)	S11 Mag	S11 Ang (Deg)	S21 Mag	S21 Ang (Deg)	S12 Mag	S12 Ang (Deg)	S22 Mag	S22 Ang (Deg)
2.0000	.756	-102.5	19.995	125.3	.030	41.7	.639	-39.1
3.0000	.750	-125.4	15.013	113.6	.034	32.7	.505	-44.0
4.0000	.750	-138.5	11.847	105.9	.036	28.0	.419	-45.3
5.0000	.751	-147.8	9.747	100.5	.038	25.2	.365	-45.6
6.0000	.749	-154.6	8.218	96.4	.039	24.2	.332	-44.7
7.0000	.748	-159.6	7.126	92.7	.039	23.1	.301	-44.5
8.0000	.748	-163.8	6.278	89.7	.039	23.1	.283	-44.1
9.0000	.748	-166.8	5.595	87.1	.040	23.1	.269	-43.3
10.0000	.745	-169.9	5.046	84.6	.041	23.3	.259	-42.9
11.0000	.748	-171.9	4.592	82.2	.042	23.7	.245	-43.1
12.0000	.746	-174.6	4.207	80.3	.042	24.1	.240	-43.0
13.0000	.750	-176.3	3.880	78.8	.042	25.2	.233	-43.1
14.0000	.745	-178.1	3.609	76.5	.043	25.8	.229	-43.3
15.0000	.748	-179.9	3.363	74.7	.043	25.6	.225	-43.6
16.0000	.746	-178.5	3.151	72.8	.043	26.7	.215	-44.6
17.0000	.743	-176.4	2.957	71.0	.044	26.9	.211	-44.5
18.0000	.747	-175.8	2.791	69.7	.045	28.2	.211	-45.9
19.0000	.740	-174.2	2.641	68.2	.045	29.4	.205	-46.9
20.0000	.743	-173.5	2.512	66.5	.046	28.9	.199	-47.4
21.0000	.741	-171.2	2.394	64.8	.045	30.6	.202	-47.8
22.0000	.741	-171.0	2.284	63.1	.047	30.7	.198	-47.5
23.0000	.741	-168.8	2.184	61.7	.048	33.5	.194	-49.6
24.0000	.741	-168.6	2.081	60.2	.049	31.3	.185	-50.0
25.0000	.740	-167.2	1.991	59.1	.050	34.6	.188	-52.4
26.0000	.736	-166.5	1.914	58.0	.050	34.4	.184	-54.0

Noise Parameters vs Frequency vs Bias
M NOISE: M:PS;A:16;C:16;DC:1;H:0;P:1;DOT:DUT_NF_M;

Freq (GHz)	F(min) Fitted (dB)	Gamma Opt Fitted Mag	Gamma Opt Fitted Angle	Normalized Rn Z0=50 Fitted	Associated Gain (dB) Fitted
2.0000	1.02	.317	32.0	.21	27.35

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5.0000      1.13      .197      55.6      .20      19.91
10.0000     1.46      .233      115.9     .17      14.93
15.0000     2.04      .284      148.9     .17      12.10
20.0000     2.43      .351      175.2     .16      10.23
25.0000     3.23      .415      -177.8    .17      8.51

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! S-Parameters vs Frequency vs Bias
! M NOISE: M:PS;A:16;C:16;DC:1;H:0;P:1;DOT:DUT_NF_M;

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! Bias# 14
! Bias Values Read:
! Vb:.859 V, Ib:.096 mA
! Vc:1.500 V, Ic:13.920 mA
! Date: 27 Mar 2003
! Time: 15:53:01
! Deembedding: ON

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Freq (GHz)	S11 Mag	S11 Ang (Deg)	S21 Mag	S21 Ang (Deg)	S12 Mag	S12 Ang (Deg)	S22 Mag	S22 Ang (Deg)
2.0000	.750	-106.4	20.474	123.8	.029	40.6	.618	-40.2
3.0000	.748	-128.6	15.251	112.3	.033	32.0	.485	-44.7
4.0000	.749	-141.2	11.977	104.8	.035	27.5	.402	-45.6
5.0000	.751	-150.0	9.831	99.6	.036	25.3	.350	-45.8
6.0000	.750	-156.5	8.287	95.6	.036	24.2	.319	-44.7
7.0000	.750	-161.2	7.167	92.1	.037	23.7	.290	-44.4
8.0000	.750	-165.1	6.312	89.1	.037	23.8	.272	-43.7
9.0000	.750	-168.2	5.623	86.6	.038	23.8	.260	-43.0
10.0000	.747	-171.1	5.073	84.1	.039	24.4	.250	-42.7
11.0000	.750	-173.0	4.607	81.8	.040	24.8	.236	-42.8
12.0000	.748	-175.6	4.225	80.0	.040	25.6	.232	-42.7
13.0000	.751	-177.2	3.899	78.0	.040	25.8	.225	-42.8
14.0000	.748	-179.1	3.621	76.1	.041	26.5	.222	-43.0
15.0000	.751	-179.4	3.379	74.4	.041	27.5	.216	-43.4
16.0000	.748	-177.6	3.163	72.5	.042	28.0	.209	-44.3
17.0000	.745	-175.8	2.968	70.9	.042	28.9	.205	-44.0
18.0000	.748	-175.0	2.803	69.4	.043	29.4	.204	-45.8
19.0000	.745	-173.6	2.664	68.0	.044	30.9	.199	-47.0
20.0000	.745	-172.8	2.522	66.6	.045	31.2	.193	-47.0
21.0000	.741	-170.5	2.397	64.6	.044	33.0	.195	-47.8
22.0000	.743	-170.5	2.295	62.9	.045	32.5	.192	-47.2
23.0000	.743	-168.6	2.186	61.7	.046	33.6	.187	-49.6
24.0000	.743	-168.1	2.091	60.2	.047	33.9	.182	-50.1
25.0000	.746	-167.0	1.999	58.5	.048	35.2	.183	-52.2
26.0000	.735	-166.0	1.926	57.8	.049	38.1	.175	-52.2

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! Noise Parameters vs Frequency vs Bias
! M NOISE: M:PS;A:16;C:16;DC:1;H:0;P:1;DOT:DUT_NF_M;

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Freq (GHz)	F(min) Fitted (dB)	Gamma Opt Fitted Mag	Gamma Opt Fitted Angle	Normalized Rn Z0=50 Fitted	Associated Gain (dB) Fitted
2.0000	1.06	.284	34.7	.21	27.59
5.0000	1.17	.181	61.2	.19	20.08
10.0000	1.51	.228	120.9	.16	15.06
15.0000	2.08	.290	151.9	.16	12.22
20.0000	2.47	.354	176.1	.16	10.28
25.0000	3.26	.422	-177.3	.17	8.60

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! S-Parameters vs Frequency vs Bias
! M NOISE: M:PS;A:16;C:16;DC:1;H:0;P:1;DOT:DUT_NF_M;

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! Bias# 15
! Bias Values Read:
! Vb:.859 V, Ib:.096 mA
! Vc:1.500 V, Ic:13.840 mA
! Date: 27 Mar 2003
! Time: 15:53:04
! Deembedding: ON

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Freq	S11 Mag	S11 Ang	S21 Mag	S21 Ang	S12 Mag	S12 Ang	S22 Mag	S22 Ang
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(GHz)	(Deg)	(Deg)	(Deg)	(Deg)
2.0000	.750	-106.4	20.471	123.8
3.0000	.748	-128.6	15.248	112.8
4.0000	.749	-141.2	11.976	104.8
5.0000	.750	-150.0	9.830	99.6
6.0000	.750	-156.5	8.284	95.6
7.0000	.750	-161.2	7.168	92.0
8.0000	.750	-165.2	6.312	89.1
9.0000	.750	-168.2	5.622	86.6
10.0000	.746	-171.1	5.069	84.1
11.0000	.751	-173.0	4.608	81.8
12.0000	.748	-175.5	4.226	80.0
13.0000	.752	-177.3	3.898	78.0
14.0000	.749	-179.1	3.622	76.2
15.0000	.751	179.3	3.380	74.4
16.0000	.748	177.6	3.163	72.6
17.0000	.744	175.9	2.964	70.9
18.0000	.748	175.1	2.804	69.5
19.0000	.745	173.8	2.659	68.0
20.0000	.745	172.8	2.519	66.2
21.0000	.747	170.7	2.408	64.6
22.0000	.743	170.8	2.291	63.0
23.0000	.738	168.3	2.183	61.6
24.0000	.741	168.0	2.082	60.3
25.0000	.737	167.3	2.009	59.3
26.0000	.739	166.6	1.919	57.9

Noise Parameters vs Frequency vs Bias
M NOISE: M:PS;A:16;C:16;DC:1;H:0;P:1;DOT:DUT_NF_M;

Freq (GHz)	F(min) Fitted (dB)	Gamma Opt Fitted Mag	Gamma Opt Fitted Angle	Normalized Rn Z0=50 Fitted	Associated Gain (dB) Fitted
2.0000	1.05	.282	34.8	.21	27.60
5.0000	1.17	.181	60.9	.19	20.08
10.0000	1.51	.228	120.2	.16	15.04
15.0000	2.07	.288	151.8	.16	12.21
20.0000	2.49	.356	175.9	.15	10.28
25.0000	3.25	.414	-178.0	.17	8.55

S-Parameters vs Frequency vs Bias
M NOISE: M:PS;A:16;C:16;DC:1;H:0;P:1;DOT:DUT_NF_M;

Bias# 16
Bias Values Read:
Vb:.861 V, Ib:.106 mA
Vc:1.500 V, Ic:15.120 mA
Date: 27 Mar 2003
Time: 15:53:06
Deembedding: ON

Freq (GHz)	S11 Mag	S11 Ang (Deg)	S21 Mag	S21 Ang (Deg)	S12 Mag	S12 Ang (Deg)	S22 Mag	S22 Ang (Deg)
2.0000	.746	-110.0	20.851	122.4	.028	39.5	.599	-41.1
3.0000	.747	-131.6	15.427	111.1	.031	31.2	.467	-45.2
4.0000	.749	-143.7	12.063	103.9	.033	27.2	.386	-45.9
5.0000	.751	-152.1	9.879	98.8	.034	25.0	.337	-45.7
6.0000	.751	-158.2	8.328	94.9	.035	24.4	.307	-44.5
7.0000	.751	-162.7	7.187	91.5	.035	24.1	.280	-44.0
8.0000	.752	-166.4	6.326	88.6	.035	24.1	.264	-43.5
9.0000	.752	-169.3	5.634	86.1	.036	24.5	.252	-42.6
10.0000	.750	-172.1	5.083	83.7	.037	25.2	.242	-42.2
11.0000	.753	-174.0	4.614	81.4	.038	25.9	.228	-42.4
12.0000	.748	-176.4	4.232	79.7	.038	26.4	.226	-42.4
13.0000	.753	-178.1	3.904	77.8	.039	27.3	.219	-42.4
14.0000	.751	-179.7	3.629	75.9	.039	27.9	.216	-42.6
15.0000	.752	178.7	3.384	74.2	.039	29.2	.211	-42.9
16.0000	.749	177.1	3.164	72.3	.040	29.7	.204	-43.9
17.0000	.747	175.4	2.974	70.7	.041	31.1	.200	-44.0
18.0000	.751	174.6	2.808	69.3	.041	31.5	.200	-45.3

19.0000	.748	173.3	2.661	67.9	.043	32.3	.195	-46.6
20.0000	.746	172.2	2.521	66.0	.044	32.2	.189	-47.0
21.0000	.748	169.8	2.405	64.4	.043	34.2	.190	-47.8
22.0000	.744	170.1	2.288	62.9	.045	35.0	.186	-47.5
23.0000	.740	168.3	2.196	61.6	.045	36.4	.181	-48.7
24.0000	.746	167.6	2.088	60.1	.047	36.3	.178	-49.9
25.0000	.748	167.1	2.001	58.7	.047	37.1	.177	-51.8
26.0000	.739	165.7	1.924	57.5	.048	37.6	.173	-52.5

Noise Parameters vs Frequency vs Bias
M NOISE: M:PS;A:16;C:16;DC:1;H:0;P:1;DOT:DUT_NF_M;

Freq (GHz)	F(min) Fitted (dB)	Gamma Opt Fitted Mag	Gamma Opt Fitted Angle	Normalized Rn Z0=50 Fitted	Associated Gain (dB) Fitted
2.0000	1.12	.255	37.1	.21	27.74
5.0000	1.22	.166	67.0	.19	20.22
10.0000	1.55	.228	125.7	.16	15.17
15.0000	2.12	.293	154.4	.16	12.28
20.0000	2.54	.360	177.4	.16	10.32
25.0000	3.31	.431	-177.2	.17	8.65

S-Parameters vs Frequency vs Bias
M NOISE: M:PS;A:16;C:16;DC:1;H:0;P:1;DOT:DUT_NF_M;

Bias# 17
Bias Values Read:
Vb:.864 V, Ib:.114 mA
Vc:1.500 V, Ic:16.560 mA
Date: 27 Mar 2003
Time: 15:53:09
Deembedding: DN

Freq (GHz)	S11 Mag	S11 Ang (Deg)	S21 Mag	S21 Ang (Deg)	S12 Mag	S12 Ang (Deg)	S22 Mag	S22 Ang (Deg)
2.0000	.741	-113.7	21.133	120.9	.027	38.4	.578	-41.9
3.0000	.745	-134.6	15.540	109.9	.030	30.4	.448	-45.6
4.0000	.750	-146.1	12.096	102.9	.031	27.0	.371	-45.7
5.0000	.752	-154.0	9.893	98.1	.032	25.4	.325	-45.4
6.0000	.752	-159.8	8.338	94.3	.033	24.8	.296	-44.2
7.0000	.752	-164.1	7.180	91.0	.033	24.9	.271	-43.5
8.0000	.754	-167.7	6.317	88.2	.034	24.9	.255	-42.9
9.0000	.753	-170.4	5.628	85.7	.035	25.8	.244	-42.0
10.0000	.752	-173.1	5.071	83.4	.035	26.1	.235	-41.6
11.0000	.754	-174.8	4.599	81.2	.036	26.9	.222	-41.6
12.0000	.752	-177.0	4.225	79.4	.036	27.5	.219	-41.6
13.0000	.755	-178.8	3.896	77.5	.037	28.9	.214	-41.8
14.0000	.752	-179.5	3.621	75.7	.037	29.1	.210	-42.0
15.0000	.753	-178.1	3.378	74.1	.038	30.8	.206	-42.3
16.0000	.752	-176.4	3.152	72.2	.039	31.1	.197	-43.1
17.0000	.748	-174.9	2.968	70.7	.039	32.6	.195	-43.1
18.0000	.752	-173.9	2.804	69.2	.040	33.2	.194	-44.9
19.0000	.749	-172.9	2.656	67.8	.041	33.4	.189	-45.6
20.0000	.748	-171.8	2.513	66.5	.042	34.3	.184	-46.0
21.0000	.748	-170.3	2.398	64.5	.042	36.9	.185	-47.1
22.0000	.748	-169.7	2.286	62.9	.042	36.7	.184	-47.1
23.0000	.749	-167.7	2.186	61.7	.044	37.6	.177	-48.5
24.0000	.745	-167.5	2.087	59.9	.046	38.6	.174	-49.2
25.0000	.749	-166.3	1.987	58.8	.047	40.4	.176	-50.7
26.0000	.746	-165.8	1.925	58.0	.048	41.3	.168	-52.9

Noise Parameters vs Frequency vs Bias
M NOISE: M:PS;A:16;C:16;DC:1;H:0;P:1;DOT:DUT_NF_M;

Freq (GHz)	F(min) Fitted (dB)	Gamma Opt Fitted Mag	Gamma Opt Fitted Angle	Normalized Rn Z0=50 Fitted	Associated Gain (dB) Fitted
2.0000	1.20	.228	39.9	.21	27.84

```

5.0000      1.27      .154      74.1      .19      20.33
10.0000     1.61      .231      130.0     .16      15.22
15.0000     2.18      .299      157.1     .16      12.33
20.0000     2.62      .365      178.5     .16      10.32
25.0000     3.42      .436     -174.8     .17      8.65

```

```

! S-Parameters vs Frequency vs Bias
! M NOISE: M:PS;A:16;C:16;DC:1;H:0;P:1;DOT:DUT_NF_M;

```

```

! Bias# 18
! Bias Values Read:
! Vb:.866 V, Ib:.124 mA
! Vc:1.500 V, Ic:17.960 mA
! Date: 27 Mar 2003
! Time: 15:53:11
! Deembedding: ON

```

Freq (GHz)	S11 Mag	S11 Ang (Deg)	S21 Mag	S21 Ang (Deg)	S12 Mag	S12 Ang (Deg)	S22 Mag	S22 Ang (Deg)
2.0000	.738	-117.3	21.263	119.5	.026	37.3	.558	-42.5
3.0000	.745	-137.3	15.569	108.9	.029	30.0	.432	-45.7
4.0000	.750	-148.2	12.064	102.1	.030	26.6	.358	-45.4
5.0000	.753	-155.8	9.863	97.4	.031	25.1	.313	-44.8
6.0000	.754	-161.3	8.315	93.6	.031	25.3	.287	-43.5
7.0000	.753	-165.3	7.142	90.5	.032	25.4	.263	-42.7
8.0000	.757	-168.8	6.280	87.8	.032	25.7	.249	-42.0
9.0000	.755	-171.4	5.594	85.4	.033	26.0	.239	-41.1
10.0000	.754	-173.8	5.042	83.2	.034	27.5	.230	-40.8
11.0000	.755	-175.6	4.565	80.9	.035	28.1	.219	-40.8
12.0000	.753	-177.5	4.197	79.3	.035	29.4	.215	-40.8
13.0000	.755	-179.3	3.877	77.5	.035	30.2	.211	-40.7
14.0000	.754	-179.0	3.598	75.7	.036	31.0	.206	-41.0
15.0000	.754	-177.5	3.357	74.0	.037	32.2	.202	-41.2
16.0000	.752	-176.2	3.125	72.3	.037	32.5	.194	-42.4
17.0000	.750	-175.1	2.950	70.9	.039	32.7	.194	-42.9
18.0000	.750	-173.5	2.784	69.4	.040	34.7	.191	-43.8
19.0000	.749	-173.3	2.649	68.0	.040	36.5	.187	-44.4
20.0000	.750	-171.5	2.487	66.0	.041	35.8	.182	-45.5
21.0000	.750	-171.0	2.390	64.7	.040	39.5	.181	-45.5
22.0000	.751	-169.4	2.265	63.0	.042	37.9	.179	-46.4
23.0000	.750	-169.0	2.179	62.3	.043	40.9	.176	-47.4
24.0000	.750	-167.3	2.066	60.5	.045	40.5	.171	-48.9
25.0000	.747	-167.2	2.009	59.2	.047	41.7	.173	-51.3
26.0000	.747	-166.1	1.901	57.8	.047	41.6	.168	-52.0

```

! Noise Parameters vs Frequency vs Bias
! M NOISE: M:PS;A:16;C:16;DC:1;H:0;P:1;DOT:DUT_NF_M;

```

Freq (GHz)	F(min) Fitted (dB)	Gamma Opt Fitted Mag	Gamma Opt Fitted Angle	Normalized Rn Z0=50 Fitted	Associated Gain (dB) Fitted
2.0000	1.28	.203	43.4	.21	27.88
5.0000	1.32	.146	81.9	.18	20.40
10.0000	1.66	.236	134.0	.16	15.26
15.0000	2.24	.302	159.5	.16	12.33
20.0000	2.72	.373	179.2	.16	10.28
25.0000	3.37	.432	-176.7	.18	8.69

```

! S-Parameters vs Frequency vs Bias
! M NOISE: M:PS;A:16;C:16;DC:1;H:0;P:1;DOT:DUT_NF_M;

```

```

! Bias# 19
! Bias Values Read:
! Vb:.866 V, Ib:.124 mA
! Vc:1.500 V, Ic:17.880 mA
! Date: 27 Mar 2003
! Time: 15:53:13
! Deembedding: ON

```

Freq	S11 Mag	S11 Ang	S21 Mag	S21 Ang	S12 Mag	S12 Ang	S22 Mag	S22 Ang
------	---------	---------	---------	---------	---------	---------	---------	---------

(GHz)	(Deg)	(Deg)	(Deg)	(Deg)
2.0000	.738	-117.3	21.255	119.5
3.0000	.745	-137.2	15.570	108.9
4.0000	.751	-148.1	12.059	102.2
5.0000	.753	-155.6	9.866	97.5
6.0000	.754	-161.1	8.312	94.0
7.0000	.753	-165.2	7.144	90.7
8.0000	.757	-168.5	6.277	88.0
9.0000	.754	-171.3	5.597	85.6
10.0000	.756	-173.4	5.039	83.5
11.0000	.755	-175.4	4.569	81.2
12.0000	.753	-177.0	4.199	79.7
13.0000	.753	-179.2	3.879	77.8
14.0000	.755	-179.5	3.596	76.0
15.0000	.754	-177.6	3.359	74.4
16.0000	.751	-176.5	3.125	72.5
17.0000	.752	-175.6	2.956	71.3
18.0000	.749	-173.8	2.788	69.7
19.0000	.744	-174.1	2.651	68.8
20.0000	.750	-171.8	2.490	66.3
21.0000	.756	-171.6	2.383	65.5
22.0000	.755	-169.9	2.260	63.4
23.0000	.747	-170.7	2.182	62.8
24.0000	.756	-167.8	2.075	60.9
25.0000	.742	-167.6	1.992	60.1
26.0000	.755	-166.4	1.918	58.4

Noise Parameters vs Frequency vs Bias
M NOISE: M:PS;A:16;C:16;DC:1;H:0;P:1;DOT:DUT_NF_M;

Freq (GHz)	F(min) Fitted (dB)	Gamma Opt Fitted Mag	Gamma Opt Fitted Angle	Normalized Rn Z0=50 Fitted	Associated Gain (dB) Fitted
2.0000	1.29	.204	43.2	.21	27.88
5.0000	1.32	.146	80.8	.19	20.39
10.0000	1.67	.246	133.8	.16	15.28
15.0000	2.24	.303	159.1	.16	12.33
20.0000	2.70	.373	178.3	.16	10.28
25.0000	3.46	.428	-177.3	.18	8.56

S-Parameters vs Frequency vs Bias
M NOISE: M:PS;A:16;C:16;DC:1;H:0;P:1;DOT:DUT_NF_M;

Bias# 20
Bias Values Read:
Vb:.869 V, Ib:.136 mA
Vc:1.500 V, Ic:19.440 mA
Date: 27 Mar 2003
Time: 15:53:16
Deembedding: ON

Freq (GHz)	S11 Mag	S11 Ang (Deg)	S21 Mag	S21 Ang (Deg)	S12 Mag	S12 Ang (Deg)	S22 Mag	S22 Ang (Deg)
2.0000	.735	-121.1	21.178	118.0	.025	36.3	.537	-42.9
3.0000	.745	-140.0	15.478	107.8	.027	29.2	.415	-45.5
4.0000	.752	-150.3	11.930	101.3	.028	26.8	.344	-44.7
5.0000	.753	-157.4	9.761	96.9	.029	25.7	.304	-43.9
6.0000	.755	-162.5	8.232	93.4	.030	25.9	.279	-42.4
7.0000	.754	-166.3	7.052	90.2	.030	26.0	.257	-41.4
8.0000	.758	-169.6	6.194	87.7	.031	26.7	.243	-40.7
9.0000	.756	-172.2	5.523	85.3	.032	27.4	.234	-39.8
10.0000	.759	-174.2	4.972	83.2	.032	28.9	.225	-39.6
11.0000	.755	-176.2	4.497	81.0	.033	29.7	.216	-39.4
12.0000	.755	-177.5	4.140	79.5	.033	31.0	.212	-39.2
13.0000	.755	-179.8	3.831	77.7	.034	32.1	.209	-39.6
14.0000	.757	-179.0	3.550	75.9	.035	32.5	.204	-39.7
15.0000	.753	-177.3	3.319	74.3	.036	34.0	.201	-40.3
16.0000	.753	-176.4	3.071	72.8	.036	35.4	.192	-40.9
17.0000	.755	-175.8	2.914	71.4	.037	36.2	.193	-41.4
18.0000	.749	-173.4	2.749	69.7	.038	37.5	.189	-41.5

19.0000	.747	174.6	2.625	69.1	.038	38.5	.187	-42.4
20.0000	.752	171.4	2.446	66.3	.040	38.4	.179	-44.0
21.0000	.767	172.5	2.357	65.7	.040	40.3	.178	-44.6
22.0000	.756	169.8	2.223	63.5	.040	40.5	.173	-46.8
23.0000	.748	171.6	2.152	63.2	.043	45.0	.176	-47.0
24.0000	.762	167.6	2.037	60.9	.042	43.2	.174	-47.4
25.0000	.742	167.8	1.972	60.5	.045	45.3	.177	-46.9
26.0000	.757	166.3	1.879	58.9	.045	45.6	.173	-51.6

! Noise Parameters vs Frequency vs Bias

! M NOISE: M:PS;A:16;C:16;DC:1;H:0;P:1;DOT:DUT_NF_M;

! Freq ! (GHz)	F(min) ! Fitted ! (dB)	Gamma Opt ! Fitted ! Mag	Gamma Opt ! Fitted ! Angle	Normalized ! Rn ZO=50 ! Fitted	Associated ! Gain (dB) ! Fitted
2.0000	1.41	.176	46.2	.21	27.80
5.0000	1.38	.141	89.5	.18	20.40
10.0000	1.73	.254	137.6	.16	15.28
15.0000	2.30	.308	160.7	.17	12.27
20.0000	2.82	.383	179.4	.16	10.19
25.0000	3.51	.433	-177.4	.18	8.51

APPENDIX G

VERILOG-A CODE OF VBIC MODEL FOR SEMI-EMPIRICAL NOISE MODEL

IMPLEMENTATION

Only the noise block is given, which is relevant to the semi-empirical noise model. Branch n_{ia} and n_{ib} consist of 1 Ohm resistance respectively. Branch b_{bei} is the intrinsic BE diode. Branch b_{cei} is the intrinsic CB current flow path.

```

...
// begin noise block

n_gm      = abs(Itzf)/(nf_t*Vtv);           // added by kejun
n_cSib    = n_Kbb*pow(n_gm,n_abb)+n_Bbb+1e-60; // added by kejun
n_cSic    = (n_Kcc*pow(n_gm,n_acc)+n_Bcc)*n_gm; // added by kejun
n_cSicib  = n_Kcb*pow(n_gm,n_acb)+n_Bcb;     // added by kejun
n_cVib    = n_cSic-n_cSicib*n_cSicib/n_cSib; // added by kejun
n_cVib    = n_cVib>0.0 ? sqrt(n_cVib) : 0.0; // added by kejun

I(n_ia)   <+ white_noise(1);               // added by kejun
I(n_ib)   <+ white_noise(1);               // added by kejun
I(n_ia)   <+ V(n_ia);                       // added by kejun
I(n_ib)   <+ V(n_ib);                       // added by kejun
I(b_bei)  <+ ddt(V(n_ia))*sqrt(n_cSib);     // added by kejun
I(b_cei)  <+ V(n_ia)*n_cSicib/sqrt(n_cSib); // changed by kejun
I(b_cei)  <+ V(n_ib)*n_cVib;                // changed by kejun
I(b_bei)  <+ white_noise(2*'QQ*abs(Ibe))
          +flicker_noise(kfn*pow(abs(Ibe),afn),bfn);
I(b_bex)  <+ white_noise(2*'QQ*abs(Ibex))
          +flicker_noise(kfn*pow(abs(Ibex),afn),bfn);
I(b_bep)  <+ white_noise(2*'QQ*abs(Ibep))
          +flicker_noise(kfn*pow(abs(Ibep),afn),bfn);
I(b_rcx)  <+ white_noise(4*'KB*Tdev*Gcx);
I(b_rci)  <+ white_noise(4*'KB*Tdev*((abs(Irci)
          +1.0e-10*Gci)/(abs(Vrci)+1.0e-10)));
I(b_rbx)  <+ white_noise(4*'KB*Tdev*Gbx);
I(b_rbi)  <+ white_noise(4*'KB*Tdev*qb*Gbi);
I(b_re)   <+ white_noise(4*'KB*Tdev*Ge);
I(b_rbp)  <+ white_noise(4*'KB*Tdev*qbp*Gbp);
I(b_cep)  <+ white_noise(2*'QQ*abs(Iccp));
I(b_rs)   <+ white_noise(4*'KB*Tdev*Gs);

// end noise block
...

```

APPENDIX H

DERIVATION OF LOW INJECTION VAN VLIET MODEL IN ADMITTANCE REPRESENTATION

H.1 Fundamentals

H.1.1 Operator

We define inner product

$$\langle f, g \rangle \equiv \int f g^* dv.$$

For operator L , its adjoint operator, \tilde{L} , is defined as

$$\langle Lf, g \rangle - \langle f, \tilde{L}g \rangle = \oint C[f, g] \cdot d\sigma. \quad (\text{H.1})$$

That is, there is only a surface integration for the difference of inner products. The surface integral is along the inner surface. Note that $\tilde{L} = (L^T)^*$, where L^T is the transpose of L , superscript $*$ denotes conjugate. If $L = \tilde{L}$, L is called self-adjoint operator. If the surface integration of a self-adjoint operator vanishes, L is a Hermitian operator.

For carrier transport in semiconductor, carrier continuity equations like (2.40), (2.44) and (2.49) should be satisfied. The carrier changing rate operators for electron and hole in frequency domain are

$$L_n = s + 1/\tau_n - \nabla \cdot \mu \vec{E} - D\nabla^2, \quad (\text{H.2})$$

$$L_p = s + 1/\tau_p + \nabla \cdot \mu \vec{E} - D\nabla^2, \quad (\text{H.3})$$

where $s = j\omega$. The diffusion coefficient D is assumed to be position independent, while the electric field is not subjected to such constraint. Their adjoint operators are

$$\tilde{L}_n = -s + 1/\tau_n + \mu \vec{E} \cdot \nabla - D \nabla^2, \quad (\text{H.4})$$

$$\tilde{L}_p = -s + 1/\tau_p - \mu \vec{E} \cdot \nabla - D \nabla^2. \quad (\text{H.5})$$

The adjoint operators are simple because the electrical field is in front of ∇ . Further, in accord with [39], we write Λ the spatial parts of these operators, i.e. $L = \Lambda + s$ and $\tilde{L} = \tilde{\Lambda} + s^*$. For example, the Λ of hole carrier is

$$\Lambda_p = 1/\tau_p + \nabla \cdot \mu \vec{E} - D \nabla^2, \quad (\text{H.6})$$

$$\tilde{\Lambda}_p = 1/\tau_p - \mu \vec{E} \cdot \nabla - D \nabla^2. \quad (\text{H.7})$$

H.1.2 Green's theorem for L_p

The Green's theorem for L_p is that for any two functions $\alpha(r)$ and $\beta(r)$, (H.1) is satisfied, explicitly

$$\int \beta^* L_p \alpha dv - \int \alpha \tilde{L}_p^* \beta^* dv = \oint [-\beta^* (D \nabla_0 - \mu \vec{E}_0) \alpha + \alpha D \nabla_0 \beta^*] \cdot d\sigma. \quad (\text{H.8})$$

The surface integral is along the inner surface.

H.1.3 Dirac delta function

The bulk delta function $\delta(r - r')$ is zero at any position except r' and $\int \delta(r - r') dv = 1$. There are many analytical $\delta(r - r')$ functions, for example $-\nabla^2 [1/(4\pi|r - r'|)]$. $\delta(r - r')$ has the following

properties:

$$\begin{aligned}
\phi(r')\delta(r-r') &= \phi(r)\delta(r-r'), \\
\nabla\delta(r-r') &= -\nabla'\delta(r-r'), \\
\phi(r')\nabla\delta(r-r') &= \phi(r)\nabla\delta(r-r') + [\nabla\phi(r)]\delta(r-r'), \\
\int \delta(r_0-r)\phi(r)dv &= \phi(r_0)/2,
\end{aligned} \tag{H.9}$$

where $\phi(r)$ can be any function, and r_0 is a point on the *smooth* boundary surface of given integration volume.

H.1.4 Λ theorem

Λ is the spatial part of operator L . The Λ theorem derived by van Vliet in [40] gives the connection between the covariance $\Gamma(r, r') \equiv \langle \Delta p(r, t)\Delta p(r', t) \rangle$ and the noise source $\xi(r, t)$ with strength $\Xi(r, r') = \frac{1}{2}S_{bulk}$, that is

$$(\Lambda_r + \Lambda_{r'})\Gamma(r, r') = \frac{1}{2}S_{bulk}(r, r'). \tag{H.10}$$

Note $\Gamma(r, r') = \Gamma(r', r)$ and $S_{bulk}(r, r') = S_{bulk}(r', r)$. Certain boundary conditions can be stated which indicate that Γ often satisfies delta-type singularities at the surface of volume V . The solution *inside* V stemming from the volume sources only will be denoted as Γ' .

H.2 Problem setup for base low injection noise of PNP transistor

We consider the low injection minority carrier (i.e. hole) noise for the base region of a PNP transistor as shown in Fig. H.1. S_α and S_β are the neutral base ending surface at EB and CB junctions. S_f is the free surface of base. S_c is the base contact surface. We allow position dependent

built-in field $E(r)$ and life time $\tau(r)$, while a position independent diffusion coefficient D . $E(r)$ should not depend on the carrier density.

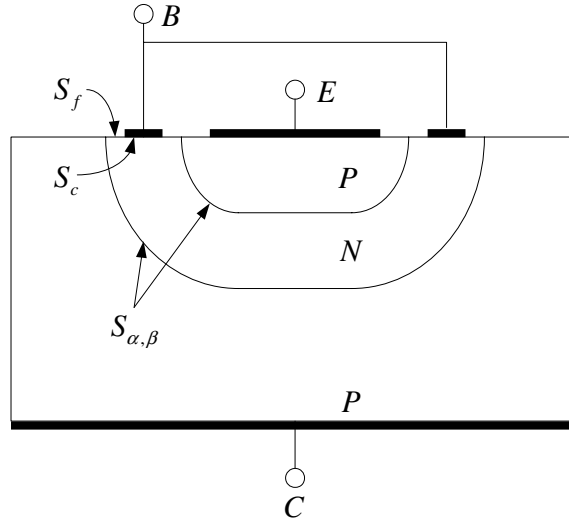


Figure H.1: Schematic geometry of a PNP transistor.

The hole continuity equation with *homogenous boundary condition* is

$$L_p p = \xi(r, s), \quad \xi(r, s) = \zeta(r, s) + \nabla \cdot \gamma(r, s), \quad (\text{H.11})$$

$$p|_{\sigma=S_\alpha, S_\beta} = 0, \quad (\text{H.12})$$

where L_p is given in (H.3), p is the hole density fluctuation. $\gamma(r, s)$ is the diffusion noise with PSD (in flux density representation, i.e. no charge units e)

$$S_\gamma(r, r') = 4Dp_s(r)\delta(r - r')\mathbb{I}, \quad (\text{H.13})$$

according to (2.35), where $p_s(r)$ is the total DC hole density. $\zeta(r, s)$ is the GR noise with PSD

$$S_\zeta(r, r') = \left\{ \frac{4p_s(r)}{\tau_p} - 2D \nabla^2 p_s(r) + 2 \nabla \cdot [\mu \vec{E}(r)p_s(r)] \right\} \delta(r - r') \quad (\text{H.14})$$

Note (H.14) is equivalent to (2.36) once $p_s(r) \gg p_{s0}(r)$, a condition well satisfied when the transistor is forward biased. $p_{s0}(r)$ is the hole density at zero bias. To provide this, we consider the DC continuity equation, which is $\Lambda_p p_s(r) = 0$. Hence,

$$S_\zeta(r, r') = \left[\frac{2p_s(r)}{\tau_p} - 2\Lambda_p p_s(r) \right] \delta(r - r') = \frac{2p_s(r)}{\tau_p} \delta(r - r') \approx \frac{2[p_s(r) + p_{s0}(r)]}{\tau_p} \delta(r - r').$$

The reason of using (H.14) instead of (2.36) will be clear when applying Λ theorem below. The total noise spectrum is

$$\begin{aligned} S_\xi(r, r') &= S_\zeta(r, r') + \nabla \cdot \nabla' \cdot S_\gamma(r, r') \\ &= \left\{ \frac{4p_s(r)}{\tau_p} - 2D \nabla^2 p_s(r) + 2 \nabla \cdot [\mu \vec{E}(r) p_s(r)] \right\} \delta(r - r') + 4D \nabla \cdot \nabla' [p_s(r) \delta(r - r')]. \end{aligned} \quad (\text{H.15})$$

Due to the assumption $p_s(r) \gg p_{s0}(r)$, the van Vliet model is not correct at zero bias. Clearly finite exit velocity effect at CB junction is not considered as of the homogenous boundary condition used.

H.3 Green's function of homogeneous boundary

Define the homogeneous boundary Green's function G^s as

$$L_p G^s(r, r', s) = \delta(r - r'), \quad G^s(r_0, r', s) = 0|_{r_0 \in S_c, S_f, S_\alpha, S_\beta}. \quad (\text{H.16})$$

If the surface recombination velocity of S_c and S_f are not infinite, boundary conditions in (H.16) are not correct. However, theoretical analysis shows that the noise results will not change [39].

Define the adjoint Green's function \tilde{G}^s as

$$\tilde{L}_p \tilde{G}^s(r, r'', s) = \delta(r - r''). \quad (\text{H.17})$$

Here r' and r'' are source positions within the volume of integration. The Green's functions are not defined when the source positions are on the boundary yet. A "good" boundary condition for \tilde{G}^s should be chosen so that reciprocity

$$G^s(r, r', s) = \tilde{G}^{s*}(r', r, s)$$

holds. This means that $\oint C[G^s(r_0, r', j\omega), \tilde{G}^{s*}(r_0, r'', s)]d\sigma$ must vanish. To provide this, \tilde{G}^s should satisfy the boundary condition according to (H.8)

$$\tilde{G}^s(r_0, r'', s) = 0|_{r_0 \in S_c, S_f, S_\alpha, S_\beta}.$$

Due to the reciprocity condition,

$$G^s(r', r_0, s) = 0|_{r_0 \in S_c, S_f, S_\alpha, S_\beta}, \quad \tilde{G}^s(r'', r_0, s) = 0|_{r_0 \in S_c, S_f, S_\alpha, S_\beta}.$$

So far the Green's functions are fully defined.

$G(r, r', s)$ has the following property: for $r = r_\alpha$ and $r' \rightarrow r_\alpha^+$,

$$\oint (D \nabla_\alpha - \mu \vec{E}_\alpha) G^s(r_\alpha, r_\alpha^+, s) \cdot d\sigma_\alpha = -1, \quad (\text{H.18})$$

where r is a point on surface α , and r' approaches to the surface α from the inside. To provide this, consider an infinite small volume ΔV enclosed by surface α and surface t as shown in Fig. H.2. The surface t is a auxiliary surface infinitely close to surface α . $r' \rightarrow r_\alpha^+$ is contained by ΔV . According to the boundary condition of $G(r, r', s)$,

$$G(r_\alpha, r_\alpha^+, s) = 0, \quad G(r_t, r_\alpha^+, s) = 0. \quad (\text{H.19})$$

and then take a volume integral of (H.16) inside ΔV ,

$$\int \nabla \cdot (\mu \vec{E} - D \nabla) G(r, r', s) dv = \int \delta(r - r') dv = 1. \quad (\text{H.20})$$

By using the Gauss theorem for the left side of (H.20), the volume integral can be transformed into a surface integral. Noticing that the surface integral on surface t is infinite small, (H.18) is then obtained. Physically, (H.18) means that when the delta current injection position is very close to surface α , then all the injected current will be collected by surface α .

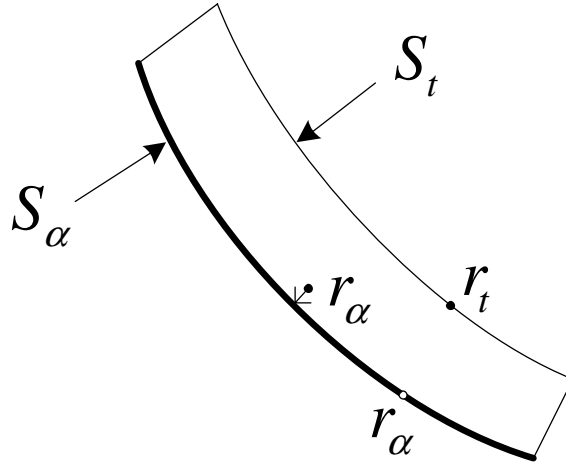


Figure H.2: Illustration of surface integral.

H.4 Hole concentration fluctuation and its spectrum

The Green's theorem with $\alpha = p(r, s)$ and $\beta = \tilde{G}^s(r, r', s)$ gives

$$p(r', s) = \int \tilde{G}^{s*}(r, r', s) \xi(r, s) dv + \oint [\tilde{G}^{s*}(r_0, r', s) (D \nabla_0 - \mu \vec{E}_0) p(r_0, s) - p(r_0, s) D \nabla_0 \tilde{G}^{s*}(r_0, r', s)] \cdot d\sigma. \quad (\text{H.21})$$

Making the changes $r' \rightarrow r$, $r \rightarrow r''$ and using the reciprocity, the hole concentration fluctuation can be obtained as

$$p(r, s) = \int G^s(r, r'', s) \xi(r'', s) dv + \oint [G^s(r, r_0, s)(D \nabla_0 - \mu \vec{E}_0)p(r_0, s) - p(r_0, s)D \nabla_0 G^s(r, r_0, s)] \cdot d\sigma. \quad (\text{H.22})$$

(H.22) is valid for G^s with any boundary condition. Especially for the homogeneous boundary condition defined for G^s , (H.22) reduces to

$$p(r, s) = \int G^s(r, r'', s) \xi(r'', s) dv. \quad (\text{H.23})$$

From (H.23), the noise spectrum of the correlation between $p(r, s)$ and $p(r', s)$ can be obtained

$$\begin{aligned} S_p(r, r', \omega) &\equiv \langle p^*(r, s)p(r', s) \rangle = \iint G^s(r, r_1, -s) \langle \xi^*(r_1, s)\xi(r_2, s) \rangle G^s(r', r_2, s) dv_1 dv_2 \\ &= \iint G^s(r, r_1, -s) S_\xi(r_1, r_2) G^s(r', r_2, s) dv_1 dv_2. \end{aligned} \quad (\text{H.24})$$

(H.24) is quadratic in Green's function, and should be transformed to be linear in Green's function using the Λ theorem.

H.4.1 van Vliet - Fasset form of noise spectrum

According to (H.10), the bulk covariance $\Gamma'(r_1, r_2)$ satisfies

$$(L_{p,r_1}^* + L_{p,r_2})\Gamma'(r_1, r_2) = (\Lambda_{p,r_1} + \Lambda_{p,r_2})\Gamma'(r_1, r_2) = \frac{1}{2}S_\xi(r_1, r_2), \quad (\text{H.25})$$

so that

$$S_p(r, r', \omega) = 2 \iint G^s(r, r_1, -s) G^s(r', r_2, s) [L_{p,r_1}^* + L_{p,r_2}] \Gamma'(r_1, r_2) dv_1 dv_2. \quad (\text{H.26})$$

Changing $r \rightarrow r_2$ and making $\alpha = \Gamma'(r_1, r_2)$ and $\beta^* = G^s(r, r_1, -s) G^s(r', r_2, s)$, the Green's theorem gives

$$\begin{aligned} \int G^s(r, r_1, -s) G^s(r', r_2, s) L_{p,r_2} \Gamma'(r_1, r_2) dv_2 &= \int \Gamma'(r_1, r_2) \tilde{L}_{p,r_2}^* G^s(r, r_1, -s) G^s(r', r_2, s) dv_2 \\ &+ \oint [-G^s(r, r_1, -s) G^s(r', r_0, s) (D \nabla_0 - \mu \vec{E}_0) \Gamma'(r_1, r_0)] \cdot d\sigma \\ &+ \oint [\Gamma'(r_1, r_0) D \nabla_0 G^s(r, r_1, -s) G^s(r', r_0, s)] \cdot d\sigma. \end{aligned} \quad (\text{H.27})$$

Similarly, Changing $r \rightarrow r_1$ and making $\alpha^* = \Gamma'(r_1, r_2)$ and $\beta = G^s(r, r_1, -s) G^s(r', r_2, s)$, the conjugate Green's theorem gives

$$\begin{aligned} \int G^s(r, r_1, -s) G^s(r', r_2, s) L_{p,r_1}^* \Gamma'(r_1, r_2) dv_1 &= \int \Gamma'(r_1, r_2) \tilde{L}_{p,r_1} G^s(r, r_1, -s) G^s(r', r_2, s) dv_1 \\ &+ \oint [-G^s(r, r_0, -s) G^s(r', r_2, s) (D \nabla_0 - \mu \vec{E}_0) \Gamma'(r_0, r_2)] \cdot d\sigma \\ &+ \oint [\Gamma'(r_0, r_2) D \nabla_0 G^s(r, r_0, -s) G^s(r', r_2, s)] \cdot d\sigma. \end{aligned} \quad (\text{H.28})$$

Now using (H.27) and (H.28), (H.26) becomes

$$\begin{aligned}
S_p(r, r', \omega) = & 2 \iint \Gamma'(r_1, r_2) [\tilde{L}_{p,r_1} + \tilde{L}_{p,r_2}^*] \tilde{G}^s(r_1, r, s) \tilde{G}^{s*}(r_2, r', s) dv_1 dv_2 \\
& + 2 \oint \int -G^s(r, r'', -s) G^s(r', r_0, s) (D \nabla_0 - \mu \vec{E}_0) \Gamma'(r'', r_0) dv'' \cdot d\sigma \\
& + 2 \oint \int \Gamma'(r'', r_0) D \nabla_0 G^s(r, r'', -s) G^s(r', r_0, s) dv'' \cdot d\sigma \\
& + 2 \oint \int -G^s(r, r_0, -s) G^s(r', r'', s) (D \nabla_0 - \mu \vec{E}_0) \Gamma'(r_0, r'') dv'' \cdot d\sigma \\
& + 2 \oint \int \Gamma'(r_0, r'') D \nabla_0 G^s(r, r_0, -s) G^s(r', r'', s) dv'' \cdot d\sigma. \tag{H.29}
\end{aligned}$$

Note that the bulk part of (H.29) can be further reduced using the definition of Green's functions

$$\begin{aligned}
S_p(r, r', \omega)|_{bulk} = & 2 \iint \tilde{G}^{s*}(r_2, r', s) \Gamma'(r_1, r_2) [\tilde{L}_{p,r_1} \tilde{G}^s(r_1, r, s)] dv_1 dv_2 \\
& + 2 \iint \tilde{G}^s(r_1, r, s) \Gamma'(r_1, r_2) [\tilde{L}_{p,r_2}^* \tilde{G}^{s*}(r_2, r', s)] dv_1 dv_2 \\
= & 2 \iint \tilde{G}^{s*}(r_2, r', s) \Gamma'(r_1, r_2) \delta(r_1 - r) dv_1 dv_2 \\
& + 2 \iint \tilde{G}^s(r_1, r, s) \Gamma'(r_1, r_2) \delta(r_2 - r') dv_1 dv_2 \\
= & 2 \int [\Gamma'(r, r'') G^s(r', r'', s) + \Gamma'(r'', r') G^s(r, r'', -s)] dv'', \tag{H.30}
\end{aligned}$$

so that

$$\begin{aligned}
S_p(r, r', \omega) = & 2 \int [\Gamma'(r, r'') G^s(r', r'', s) + \Gamma'(r'', r') G^s(r, r'', -s)] dv'' \\
& + 2 \oint \int -G^s(r, r'', -s) G^s(r', r_0, s) (D \nabla_0 - \mu \vec{E}_0) \Gamma'(r'', r_0) dv'' \cdot d\sigma \\
& + 2 \oint \int \Gamma'(r'', r_0) D \nabla_0 G^s(r, r'', -s) G^s(r', r_0, s) dv'' \cdot d\sigma \\
& + 2 \oint \int -G^s(r, r_0, -s) G^s(r', r'', s) (D \nabla_0 - \mu \vec{E}_0) \Gamma'(r_0, r'') dv'' \cdot d\sigma \\
& + 2 \oint \int \Gamma'(r_0, r'') D \nabla_0 G^s(r, r_0, -s) G^s(r', r'', s) dv'' \cdot d\sigma. \tag{H.31}
\end{aligned}$$

This is the van-Fasset form whose main part is linear in Green's functions. (H.31) is valid for G^s with any boundary condition for the hole density fluctuation caused by *bulk* noise sources. Particularly, for the homogeneous boundary condition of G^s , $G^s(r, r_0, s) = 0$. All surface integrals in (H.31) vanish, therefore

$$S_p(r, r', \omega) = 2 \int [\Gamma'(r, r'')G^s(r', r'', s) + \Gamma'(r'', r')G^s(r, r'', -s)] dv''. \quad (\text{H.32})$$

H.4.2 Solution for Λ theorem at low injection

For low injection, the Λ theorem with the source (H.15) and Λ (H.7) is

$$\begin{aligned} & \left[\frac{2}{\tau_p} + \nabla \cdot \mu \vec{E}(r) - D \nabla^2 + \nabla' \cdot \mu \vec{E}(r') - D \nabla'^2 \right] \Gamma'(r, r') \\ & = \left\{ \frac{2p_s(r)}{\tau_p} - D \nabla^2 p_s(r) + \nabla \cdot [\mu \vec{E}(r)p_s(r)] \right\} \delta(r - r') + 2D \nabla \cdot \nabla' [p_s(r)\delta(r - r')]. \end{aligned} \quad (\text{H.33})$$

Using the properties of delta function in (H.9), one finds that (H.33) admits the solution

$$\Gamma'(r, r') = p_s(r)\delta(r - r'). \quad (\text{H.34})$$

The derivation manifests the value of using $\Lambda p_s(r) = 0$ in the GR noise source as discussed in Section H.2. With (H.34) and (H.32), the spectrum of hole fluctuation for homogeneous boundary condition is

$$S_p(r, r', \omega) = 2p_s(r)G^s(r', r, s) + 2p_s(r')G^s(r, r', -s). \quad (\text{H.35})$$

H.5 Terminal noise current spectrum

The operator to transform carrier density into current density is $(e\mu\vec{E} - eD\nabla)$ for hole. The total hole current density at given point r is

$$j(r, t) = e(\mu\vec{E} - D\nabla)p(r, t) - e\gamma(r, t) = j^o(r, t) - e\gamma(r, t), \quad (\text{H.36})$$

where $j^o(r, t)$ is the response fluctuation current density

$$j^o(r, t) = e(\mu\vec{E} - D\nabla)p(r, t). \quad (\text{H.37})$$

Therefore, the spectrum of is

$$S_j(r, r', \omega) = S_{j^o}(r, r', \omega) - S_{j^o, e\gamma}(r, r', \omega) - S_{e\gamma, j^o}(r, r', \omega) + e^2 S_\gamma(r, r', \omega). \quad (\text{H.38})$$

The current spectrum due to γ is

$$S_{j_\gamma}(\omega) = e^2 \oint \oint S_\gamma(r_\alpha, r_\alpha^+, \omega) \cdot d\sigma_\alpha \cdot d\sigma_\alpha^+ = e^2 \oint \oint 4Dp_s(r_\alpha)\delta(r_\alpha - r_\alpha^+)d\sigma_\alpha \cdot d\sigma_\alpha^+ = 0. \quad (\text{H.39})$$

In the following, the rest three components are calculated.

H.5.1 Spectrum due to j^o

The correlation spectrum of j^o , $\langle j^{o*}(r)j^o(r') \rangle$, is

$$\begin{aligned}
S_{j^o}(r, r', \omega) &= 2e^2(\vec{\mu}\vec{E} - D\nabla)(\vec{\mu}\vec{E}' - D\nabla')[p_s(r)G^s(r', r, s) + p_s(r')G^s(r, r', -s)] \\
&= 2e^2 p_s(r')(D\nabla - \vec{\mu}\vec{E}')D\nabla' G^s(r, r', -s) \\
&\quad + 2e^2 \left\{ (D\nabla' - \vec{\mu}\vec{E}')p_s(r') \right\} (D\nabla - \vec{\mu}\vec{E})G^s(r, r', -s) \\
&\quad + 2e^2 p_s(r)(D\nabla' - \vec{\mu}\vec{E}')D\nabla G^s(r', r, s) \\
&\quad + 2e^2 \left\{ (D\nabla - \vec{\mu}\vec{E})p_s(r) \right\} (D\nabla' - \vec{\mu}\vec{E}')G^s(r', r, s) \tag{H.40}
\end{aligned}$$

The reason of separation will be clear when it is connected to Y-parameters below.

Now the correlation PSD of two different terminal α and terminal β ($\alpha \neq \beta$) is,

$$\begin{aligned}
S_{i_\alpha^o i_\beta^o}(\omega) &= \oint \oint S_{j^o}(r, r', \omega) \cdot d\sigma_\alpha \cdot d\sigma_\beta \Big|_{r=r_\alpha, r'=r_\beta} \\
&= \oint \oint 2e^2 p_s(r_\beta)(D\nabla_\alpha - \vec{\mu}\vec{E}_\alpha)D\nabla_\beta G^s(r_\alpha, r_\beta, -s) \cdot d\sigma_\alpha \cdot d\sigma_\beta \\
&\quad + \oint \oint 2e^2 p_s(r_\alpha)(D\nabla_\beta - \vec{\mu}\vec{E}_\beta)D\nabla_\alpha G^s(r_\beta, r_\alpha, s) \cdot d\sigma_\alpha \cdot d\sigma_\beta. \tag{H.41}
\end{aligned}$$

For the auto-correlation PSD of terminal α , $r = r_\alpha$ and $r' = r_\alpha$ cannot be set simultaneously, since the derivative of $G(r_\alpha, r_\alpha, s)$ cannot be defined. The trick is to set $r = r_\alpha$ and let $r' \rightarrow r_\alpha^+$ (or to set $r' = r_\alpha$ and let $r \rightarrow r_\alpha^+$). Here the superscript + indicates that the surface position is approached from the inside (consistent with the Green's theorem). Note that

$$e(D\nabla_\alpha - \vec{\mu}\vec{E}_\alpha)p_s(r_\alpha) = -J_\alpha^{DC}(r_\alpha), \quad \oint J_\alpha^{DC}(r_\alpha) \cdot d\sigma_\alpha = I_\alpha$$

Then the auto-correlation PSD of terminal α is

$$\begin{aligned}
S_{i_\alpha^{os*} i_\alpha^o}(\omega) &= \oint \oint S_{j^o}(r, r', \omega) \cdot d\sigma_\alpha \cdot d\sigma_\alpha |_{r=r_\alpha, r' \rightarrow r_\alpha^+} \\
&= \oint \oint 2e^2 p_s(r_\alpha^+) (D \nabla_\alpha - \mu \vec{E}_\alpha) D \nabla_\alpha^+ G^s(r_\alpha, r_\alpha^+, -s) \cdot d\sigma_\alpha \cdot d\sigma_\alpha^+ \\
&\quad + \oint \oint 2e^2 p_s(r_\alpha) (D \nabla_\alpha^+ - \mu \vec{E}_\alpha^+) D \nabla_\alpha G^s(r_\alpha^+, r_\alpha, s) \cdot d\sigma_\alpha \cdot d\sigma_\alpha^+ \\
&\quad - \oint 2e J_\alpha^{DC}(r_\alpha) \oint (D \nabla_\alpha - \mu \vec{E}_\alpha) G^s(r_\alpha, r_\alpha^+, -s) \cdot d\sigma_\alpha \cdot d\sigma_\alpha^+ \\
&= \oint \oint 2e^2 p_s(r_\alpha^+) (D \nabla_\alpha - \mu \vec{E}_\alpha) D \nabla_\alpha^+ G^s(r_\alpha, r_\alpha^+, -s) \cdot d\sigma_\alpha \cdot d\sigma_\alpha^+ \\
&\quad + \oint \oint 2e^2 p_s(r_\alpha) (D \nabla_\alpha^+ - \mu \vec{E}_\alpha^+) D \nabla_\alpha G^s(r_\alpha^+, r_\alpha, s) \cdot d\sigma_\alpha \cdot d\sigma_\alpha^+ \\
&\quad + 2e I_\alpha.
\end{aligned} \tag{H.42}$$

H.5.2 Spectrum due to correlation of j^o and γ

Similar to the derivation of $S_p(r, r', \omega)$, using (H.23) and (2.35), $S_{p^*, \gamma}(r, r', \omega)$ can be obtained as

$$S_{p^*, \gamma}(r, r', \omega) = 4D \int G^s(r, r'', -s) \nabla'' [p_s(r') \delta(r'' - r')] = -4D p_s(r') \nabla' G^s(r, r', -s), \tag{H.43}$$

since the surface integral vanishes. Further,

$$S_{j^{os*}, \gamma}(r_\alpha, r_\beta, \omega) = 4e D p_s(r_\beta) (D \nabla_\alpha - \mu \vec{E}_\alpha) \nabla_\beta G^s(r_\alpha, r_\beta, -s), \tag{H.44}$$

and finally

$$S_{i_\alpha^{os*}, e \int \gamma_\beta \cdot d\sigma_\beta}(\omega) = e^2 \oint \oint 4D p_s(r_\beta) (\mu \vec{E}_\alpha - D \nabla_\alpha) \nabla_\beta G^s(r_\alpha, r_\beta, -s) \cdot d\sigma_\alpha \cdot d\sigma_\beta. \tag{H.45}$$

Similarly,

$$S_{e \int \gamma_\alpha^* d\sigma_\alpha, i_\beta^o}(\omega) = e^2 \oint \oint 4Dp_s(r_\alpha)(\mu \vec{E}_\beta - D \nabla_\beta) \nabla_\alpha G^s(r_\beta, r_\alpha, s) \cdot d\sigma_\beta \cdot d\sigma_\alpha. \quad (\text{H.46})$$

H.5.3 Terminal total noise current density spectrum

The correlation PSD of two different terminal α and terminal β ($\alpha \neq \beta$) is,

$$\begin{aligned} S_{i_\alpha^*, i_\beta}(\omega) &= S_{i_\alpha^{o*}, i_\beta^o}(\omega) - S_{i_\alpha^{o*}, e \int \gamma_\beta \cdot d\sigma_\beta}(\omega) - S_{e \int \gamma_\alpha^* \cdot d\sigma_\alpha, i_\beta^o}(\omega) \\ &= - \oint \oint 2e^2 p_s(r_\beta)(D \nabla_\alpha - \mu \vec{E}_\alpha) D \nabla_\beta G^s(r_\alpha, r_\beta, -s) \cdot d\sigma_\alpha \cdot d\sigma_\beta \\ &\quad - \oint \oint 2e^2 p_s(r_\alpha)(D \nabla_\beta - \mu \vec{E}_\beta) D \nabla_\alpha G^s(r_\beta, r_\alpha, s) \cdot d\sigma_\alpha \cdot d\sigma_\beta. \end{aligned} \quad (\text{H.47})$$

The auto-correlation PSD of terminal α is,

$$\begin{aligned} S_{i_\alpha^*, i_\alpha}(\omega) &= S_{i_\alpha^{o*}, i_\alpha^o}(\omega) - S_{i_\alpha^{o*}, e \int \gamma_\beta \cdot d\sigma_\beta}(\omega)|_{r_\beta=r_\alpha^+} - S_{e \int \gamma_\alpha^* \cdot d\sigma_\alpha, i_\beta^o}(\omega)|_{r_\beta=r_\alpha^+} \\ &= - \oint \oint 2e^2 p_s(r_\alpha^+)(D \nabla_\alpha - \mu \vec{E}_\alpha) D \nabla_\alpha^+ G^s(r_\alpha, r_\alpha^+, -s) \cdot d\sigma_\alpha \cdot d\sigma_\alpha^+ \\ &\quad - \oint \oint 2e^2 p_s(r_\alpha)(D \nabla_\alpha^+ - \mu \vec{E}_\alpha^+) D \nabla_\alpha G^s(r_\alpha^+, r_\alpha, s) \cdot d\sigma_\alpha \cdot d\sigma_\alpha^+ \\ &\quad + 2eI_\alpha. \end{aligned} \quad (\text{H.48})$$

H.6 Y-parameters in homogeneous Green's function

We supply small signal v_β at surface β and measure the small signal current that flows into surface α , then $Y_{\alpha\beta} \equiv i_\alpha/v_\beta$. Denote the small signal hole carrier density $p(r)$. We need to solve $p(r)$ for equation

$$L_p p(r) = 0, \quad p(r_\alpha) = 0, \quad p(r_\beta) = ep_s(r_\beta)/kTv_\beta.$$

To do this, we insert $\alpha = p(r)$, $\beta = \tilde{G}^s(r, r', s)$ into (H.8), with boundary condition of both $p(r)$ and Green's function, we at once obtain (r' is substituted with r)

$$p(r) = -\oint p(r_\beta) D \nabla_\beta G^s(r, r_\beta, s) \cdot d\sigma_\beta. \quad (\text{H.49})$$

With the current operator ($e\mu\vec{E} - eD\nabla$) for hole carrier, we obtain the Y-parameter as

$$Y_{\alpha\beta} = -\frac{e^2}{kT} \oint \oint p_s(r_\beta) (D \nabla_\alpha - \mu\vec{E}_\alpha) D \nabla_\beta G^s(r, r_\beta, s) \cdot d\sigma_\alpha \cdot d\sigma_\beta. \quad (\text{H.50})$$

Let $\beta \rightarrow \alpha^+$ for (H.50), $Y_{\alpha\alpha}$ can be obtained as

$$\begin{aligned} Y_{\alpha\alpha} &= -\frac{e^2}{kT} \oint \oint p_s(r_\alpha^+) (D \nabla_\alpha - \mu\vec{E}_\alpha) D \nabla_\alpha^+ G^s(r, r_\alpha^+, s) \cdot d\sigma_\alpha \cdot d\sigma_\alpha^+ \\ &= -\frac{e^2}{kT} \oint \oint p_s(r_\alpha) (D \nabla_\alpha^+ - \mu\vec{E}_\alpha^+) D \nabla_\alpha G^s(r, r_\alpha, s) \cdot d\sigma_\alpha \cdot d\sigma_\alpha^+. \end{aligned} \quad (\text{H.51})$$

The second step of (H.51) follows from symmetry.

H.7 Relation between Y-parameter and noise spectrum

Comparing the Y-parameters in (H.51) and (eq:Yab) with the noise spectrum in (H.48) and (H.47), their relation can be summarized as

$$S i_\alpha^*, i_\beta(\omega) = 2kT(Y_{\beta\alpha} + Y_{\alpha\beta}^*) + \delta_{\alpha\beta} 2eI_\alpha, \quad (\text{H.52})$$

where $\delta_{\alpha\beta}$ is the Kronecker delta. (H.52) is the van Vliet model in common-base configuration.

Note the terminal DC current I_α takes the positive sign when it flows outward from the device and the e should be $-e$ for NPN transistor.

H.7.1 Common-base noise for BJTs

The PSD of i_e^{CB} and i_c^{CB} noise currents for BJTs in common-base configuration as shown in Fig. H.3 (a) can be obtained from (H.52) directly

$$\begin{aligned}
 S_{ie}^{CB} &= 4kT\Re(Y_{11}^{CB}) - 2qI_E, \\
 S_{ic,ie^*}^{CB} &= 2kT(Y_{21}^{CB} + Y_{12}^{*CB}), \\
 S_{ic}^{CB} &= 4kT\Re(Y_{22}^{CB}) + 2qI_C.
 \end{aligned} \tag{H.53}$$

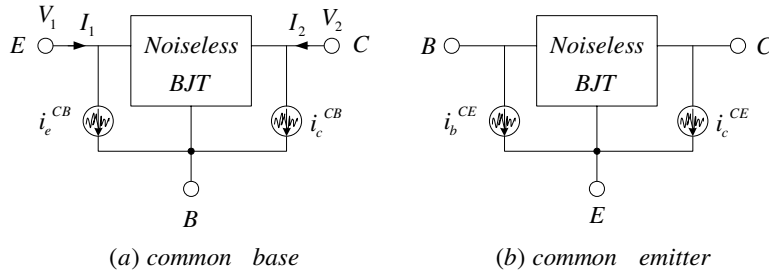


Figure H.3: Admittance representation for BJT noise: (a) Common-base; (b) Common-emitter.

H.7.2 Common-emitter noise for BJTs

Comparing Fig. H.3 (a) with Fig. H.3 (a), we have $i_b^{CE} = -i_e^{CB} - i_c^{CB}$ and $i_c^{CE} = i_c^{CB}$. Therefore the PSD of i_b^{CE} and i_c^{CE} is

$$\begin{aligned}
 S_{ib}^{CE} &= S_{ie}^{CB} + S_{ic}^{CB} + 2\Re[S_{ic,ie^*}^{CB}] = 4kT\Re(Y_{11}^{CB} + Y_{21}^{CB} + Y_{12}^{CB} + Y_{22}^{CB}) - 2qI_B, \\
 S_{ic,ib^*}^{CE} &= -S_{ic}^{CB} - S_{ic,ie^*}^{CB} = -2kT(Y_{21}^{CB} + Y_{22}^{CB} + Y_{12}^{*CB} + Y_{22}^{*CB}) - 2qI_C, \\
 S_{ic}^{CE} &= S_{ic}^{CB} = 4kT\Re(Y_{22}^{CB}) + 2qI_C.
 \end{aligned} \tag{H.54}$$

Now derive the Y-parameter relations between the common-base and common-emitter configurations. V_1 , V_2 , I_1 and I_2 defined in Fig. H.3 (a) satisfy

$$\begin{bmatrix} I_1 \\ I_2 \end{bmatrix} = \begin{bmatrix} Y_{11}^{CB} & Y_{12}^{CB} \\ Y_{21}^{CB} & Y_{22}^{CB} \end{bmatrix} \begin{bmatrix} V_1 \\ V_2 \end{bmatrix}. \quad (\text{H.55})$$

V_1 , V_2 , I_1 and I_2 also satisfy

$$\begin{bmatrix} -I_1 - I_2 \\ I_2 \end{bmatrix} = \begin{bmatrix} Y_{11}^{CE} & Y_{12}^{CE} \\ Y_{21}^{CE} & Y_{22}^{CE} \end{bmatrix} \begin{bmatrix} -V_1 \\ V_2 - V_1 \end{bmatrix}. \quad (\text{H.56})$$

According to (H.55) and (H.56),

$$\begin{bmatrix} Y_{11}^{CE} & Y_{12}^{CE} \\ Y_{21}^{CE} & Y_{22}^{CE} \end{bmatrix} = \begin{bmatrix} Y_{11}^{CB} + Y_{12}^{CB} + Y_{21}^{CB} + Y_{22}^{CB} & -Y_{12}^{CB} - Y_{22}^{CB} \\ -Y_{21}^{CB} - Y_{22}^{CB} & Y_{22}^{CB} \end{bmatrix}. \quad (\text{H.57})$$

Finally, with (H.57) and (H.54), the van Vliet model in common-emitter configuration can be obtained

$$\begin{aligned} S_{ib}^{CE} &= 4kT\Re(Y_{11}^{CE}) - 2qI_B, \\ S_{ic,ib^*}^{CE} &= 2kT(Y_{21}^{CE} + Y_{12}^{*CE}) - 2qI_C, \\ S_{ic}^{CE} &= 4kT\Re(Y_{22}^{CE}) + 2qI_C. \end{aligned} \quad (\text{H.58})$$